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QUARTERLY REPORT

TRENDS AND TECHNIQUES FOR SPACE BASE ELECTRONICS

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QUARTERLY REPORT
TRENDS AND TECHNIQUES FOR
SPACE BASE ELECTRONICS

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for

NASA Contract NAS8-26749

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JUN 12 1978

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1. DOUBLE-LEVEL METALLIZATION TECHNIQUES

Most of the work during the first quarter was directed toward the development of a sputtering system for preparing aluminum and aluminum-alloy films. A photograph of the completed system is shown in Figure 1.1. Briefly, the system consists of the following.

The basic vacuum system is a Varian-NRC 6 inch oil diffusion and mechanical roughing pump equipped for automatic and manual operation. The diffusion pump is equipped for LN₂ cooling of the cold trap. The sputter gun and power supply were obtained from Sloan Technology. The sputtering chamber was designed and built at Mississippi State. It consists of a Corning 12X18 glass cylinder and an aluminum top plate machined to accommodate up to three sputter guns. A cold cathode discharge gauge was constructed and installed in the baseplate of the chamber to measure the pressure during the sputtering operation. A throttle valve with several threaded holes for accommodating plugs is operated by one of two mechanical feedthroughs in the baseplate. A lift mechanism with a reversible motor was designed and constructed for raising the top plate and sputter guns.

Inside the chamber is equipped with a rotating table which accommodates up to eight wafers of 1½-2" in diameter. The table is driven by a vacuum sealed shaded pole motor through a magnetic coupling at 7 rpm. The entire motor-table assembly is rotated by a chain-sprocket-mechanical feedthrough arrangement through three sputter-gun and two mask positions. The mask is attached to the rotating assembly and provides one hole through which the sputter-gun deposits metal on the wafers. A crystal film thickness sensor is located beneath the sputter-gun and receives a deposit through a hole at an unused wafer position on the table.

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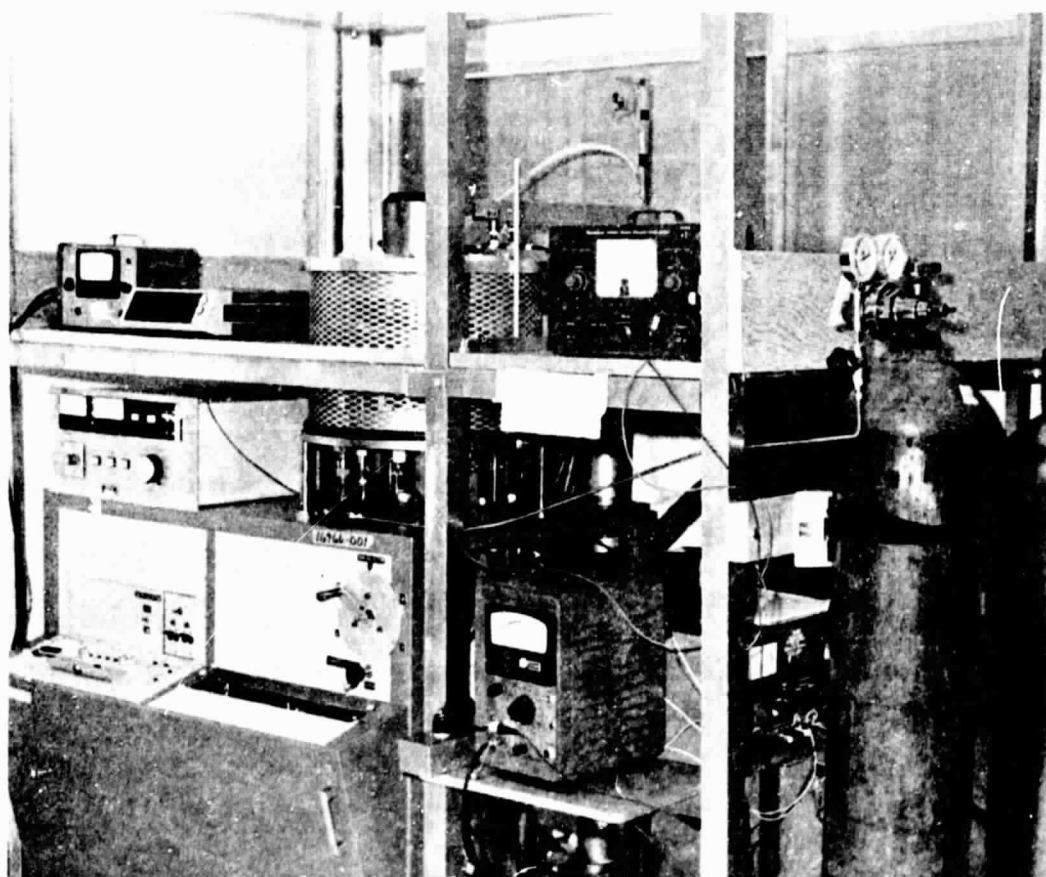


Figure 1.1 Photograph of metallization system
using sputter-gun source.

The sputtering chamber opens into a class 100 clean bench in order to maintain a high level of cleanliness. The system is located in the metallizing and bonding room of the microelectronics laboratories in Simrall Engineering Building, and this room was designed with air conditioning and filtering units to maintain a class 30,000 environment. The entire system has been constructed and checked out and is ready for depositing sputtered films.

The installation of a six-tube Thermco Ranger diffusion furnace was completed with the addition of a venting system for exhausting the scavenger boxes. All that remains to be done is to line the tube and connect the nitrogen ambient source in order to anneal the aluminum films.

2. TWO-DIMENSIONAL MODELS FOR MOS TRANSISTORS

The work done during the first quarter was directed toward preliminary investigations of numerical schemes and computational algorithms for solving the semiconduction equations for a two-dimensional field.

A recent report has described the application of the finite-element method to the analysis of a JFET.¹ The finite-element method has been used for some time in solving problems in mechanics and elasticity; however, it has only recently been applied to semiconduction problems. This method has the power to treat some problems, such as eigen-value problems, for which the finite-difference method is awkward if at all applicable. It can also be applied to the solution of field distributions governed by partial differential equations, and one of the most attractive features as compared to the finite-element method is purported to be the ease of treating non-rectangular geometries and irregular boundaries. For example, the geometry of the VMOS structure could be accommodated. It was decided to further investigate this technique.

In order to better understand the applicability of the method, it was applied to a one-dimensional linear diffusion problem. This simple problem is one for which familiar results are available for comparison and at the same time taxes the finite-element method. In its most valid form, the finite element method is applicable to variational problems in which a true minimum of an energy-related function exists. Such a minimum does not apply for the semiconductor problem in which current flow occurs by diffusive and conductive mechanisms. It has been proposed that a "weak form", the so-called Galerkin method, be applied to such problems.² The typical semiconductor problem is a non-linear boundary value and initial condition problem of which the linear diffusion problem is a very special case. In the example chosen, the diffusion variable, u , obeys:

$$u(x,t)|_{x=0} = u_s = 1 \quad (a) \quad (2.1)$$

$$u_x(x,t)|_{x=a} = 0 \quad (b)$$

$$u(x,t)|_{t=0} = \begin{matrix} 1, & x=0 \\ 0, & x>0 \end{matrix} \quad (c)$$

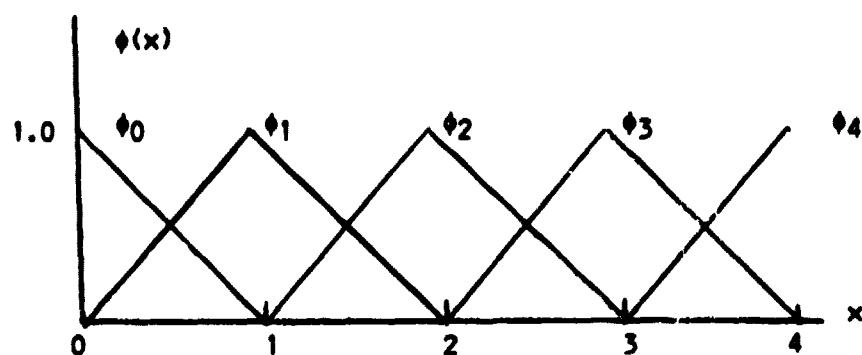
$$u_t - u_{xx} = f(x,t) = 0 \quad 0 \leq x \leq a \quad (2.2)$$

The Galerkin formulation of this problem is:

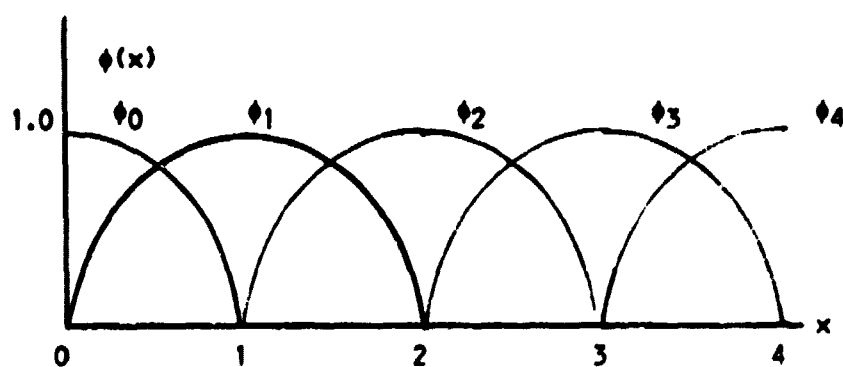
$$\int_0^a (u_t v - u_x v_x - f v) dx = 0, \quad (2.3)$$

where $v(x,t)$ represents a "trial function" which is used to approximate $u(x,t)$.

The finite element method uses a set of "hill functions" as illustrated in Figure 2.1 to construct the $v(x,t)$ approximation. Two of the popular hill functions are the Hermite bicubic and the bilinear functions which are illustrated in the figure and were used in the example. The final form of the approximate solution is;



(a) Bilinear hill functions



(b) Bicubic (Hermite) hill functions

Figure 2.1 Illustration of hill functions used in finite element method.

$$v(x,t) = \sum_{i=1}^N q_i(t) \phi_i(x). \quad (2.4)$$

On the node points the solution is approximated by the set $\{q_i(t)\}$ for the type of hill functions which overlap as illustrated in Figure 2.1. Solution for the set $\{q_i(t)\}$ is then analogous to solving for the set $\{u_i(t)\}$ on the node points using the finite difference technique. The equations for the set $\{q_i(t)\}$ are obtained by substituting (2.4) into (2.3).

$$\sum_{i=1}^N \int_0^a \left(\frac{\partial q_i}{\partial t} \phi_i \phi_j + q_i \frac{\partial \phi_i}{\partial x} \frac{\partial \phi_j}{\partial x} + f \phi_j \right) dx = 0$$

$$j = 1, 2, 3, \dots, N \quad (2.5)$$

From (2.5) a set of time differential equations is obtained which is solved using an implicit numerical method.

The solution of the problem posed by the example is closely approximated by the erfc function in the range $0 \leq x \leq 3$ if $a = 6$, and this solution was used to compare the accuracy of the finite element and finite difference methods. Figures 2.2-2.4 show the maximum error as a function of the reciprocal of the number of grid points and the size of the time step, i.e. $\lambda^2 = \Delta t / \Delta x^2$.

The error obtained in the solution by the bilinear finite element method is very nearly the same as that obtained with the finite difference method. This was not surprising because the system of equations for $\{q_i(t)\}$ and $\{u_i(t)\}$ were quite similar. What was surprising was that the Hermite bicubic finite element produced such poor results, although this surprise was based upon the intuition that since this element was more difficult to use it should provide some reward for the difficulty.

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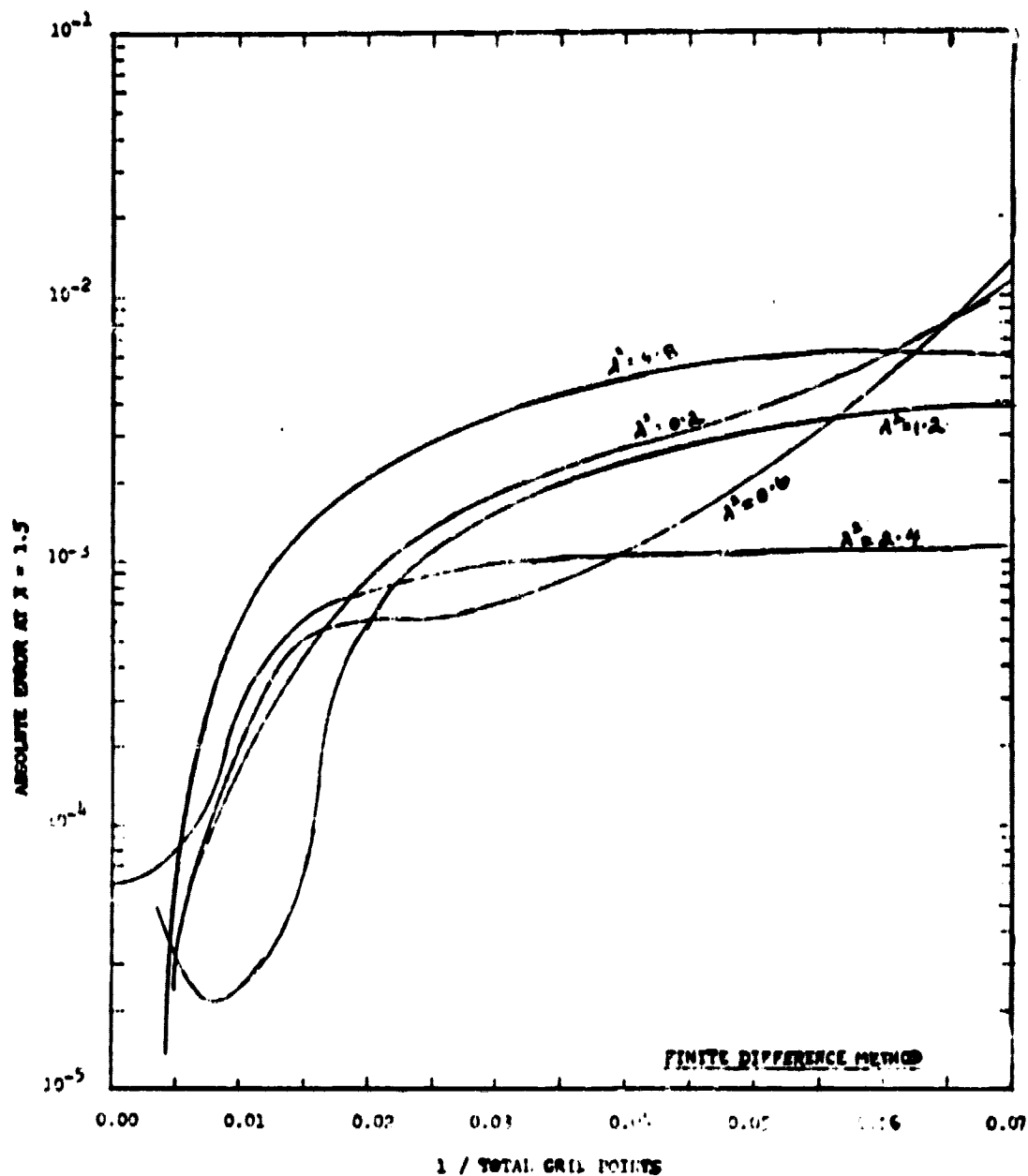


Figure 2.2 Error for finite-difference vs. reciprocal of total number of grid points,

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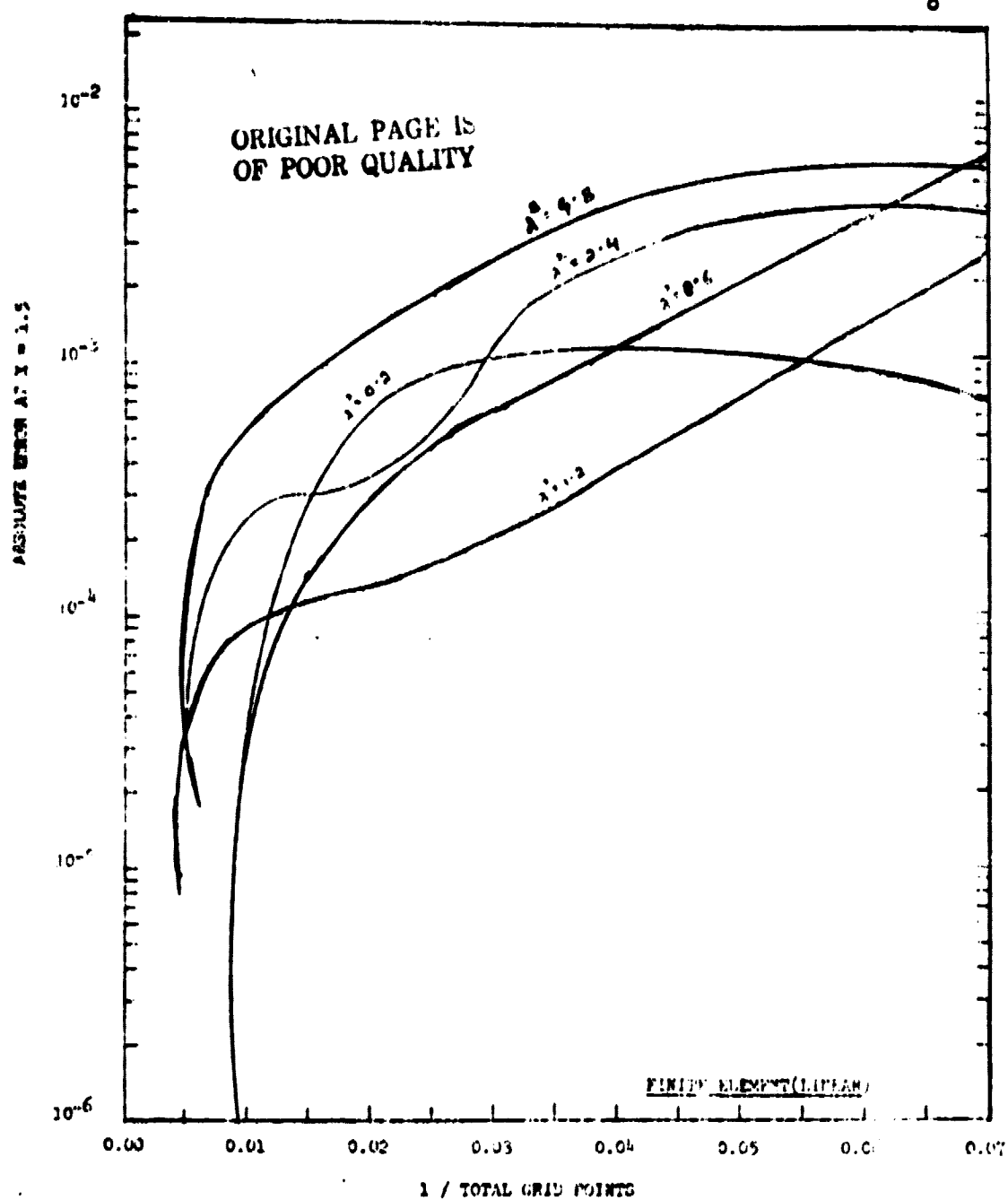


Figure 2.3 Error for finite-bilinear element vs. reciprocal of total number of grid points.

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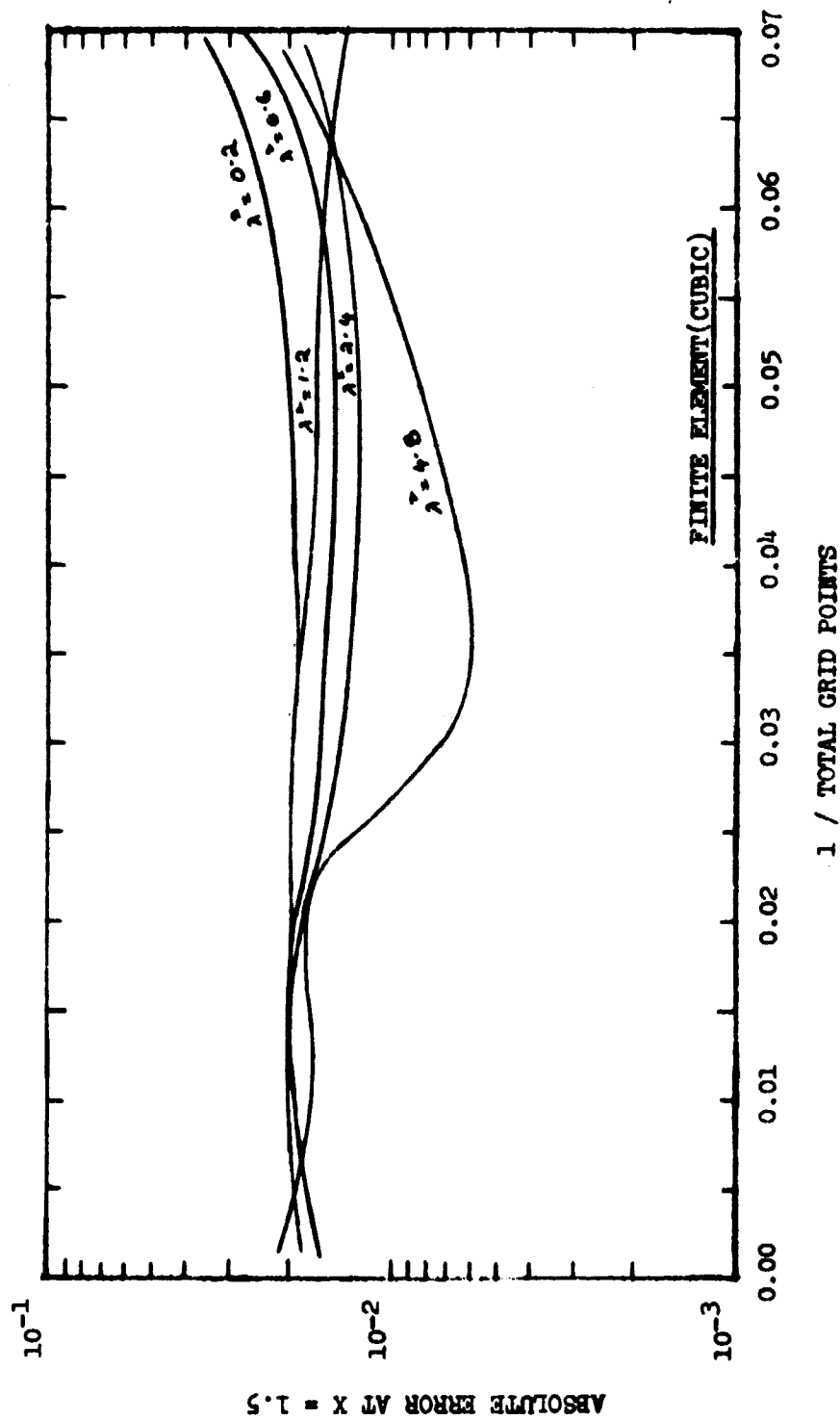


Figure 2.4 Error for finite-bicubic-element vs. reciprocal of total number of grid points.

This experience resulted in some skepticism that the finite element method would be effective for semiconductor problems. A more recent paper has reinforced this attitude.³ This paper indicates that the proper formulations of the semiconductor problem for the finite element approach remain to be demonstrated, and, in agreement with our observations, point out that the application of Galerkin's method is subject to skepticism. Therefore, it was concluded that the further work should be based upon the finite-difference method which we have used before although the finite-element method is intriguing and may be further developed in the future.

The second phase of this program is underway to develop a computational program with which to generate data from a model. During the past quarter, the major emphasis was upon deriving a simple two-dimensional algorithm which could be economically used in a simulation program during its development. It is plausible that this algorithm can be later modified to become adequate for modeling of other effects which are significant in certain situations, e.g., short channel effects, avalanche breakdown, etc.

During the past quarter an algorithm has been developed based upon the usual assumption that the mobile carriers are included in an infinitesimally thick layer of charge at the Si-SiO₂ interface. The current flow is then described by a one-dimensional equation:

$$i = \frac{kT}{q} \mu_N \left(\frac{\partial \mu_L}{\partial x} S + \frac{q \mu_L}{kT} E_s S \right), \quad 0 \leq x \leq a \quad (2.6)$$

where i and S are channel current and charge per unit channel width, E_s is the tangential interface field and μ_N and μ_L are the mobility factors accounting respectively for gate modulation and hot electron effects. This equation is solved iteratively with Poisson's equation which includes two-

dimensional effects:

$$\nabla^2 \psi = -\rho/\epsilon. \quad (2.7)$$

Equation (2.7) will be solved for one segment of a periodic structure with respect to x and equation (2.6) will be integrated to produce auxiliary equations for the boundary conditions at the Si-SiO₂ interface. It will be assumed initially that $S = 0$ at $x = a$, the point at which the normal component of the interface field changes sign. The solution algorithm then proceeds in an iterative fashion to solve (2.6) and (2.7) simultaneously for the potential distribution from which the current, i , is ultimately calculated as a function of the gate, drain and body voltage.

The model at this point admittedly has some short-comings, mainly due to the neglect of generation-recombination mechanisms. Therefore, it will not treat impact avalanche and bulk generated leakage currents. It is believed at this time that such effects can be treated by adding another iterative loop to the algorithm. The major emphasis at this point will be the development of a program for input and output data management and including subroutines which generate data internally within the program and solve systems of equations which will be encountered in implementing the algorithm.

3. REDISTRIBUTION DIFFUSIONS FOR ION-IMPLANTED PREDEPOSITS OF BORON AND PHOSPHORUS IN SOS FILMS.

The objective of this work was to produce curves describing the variation with diffusion time and temperature of the junction depth, sheet resistance and integrated impurity dose. This data has been generated for boron and phosphorus redistributed in nitrogen, dry oxygen and steam ambients for <111> oriented SOS films. The following section presents discussions of the implantation and redistribution model, further program develop, the computational procedure and of the computed results.

3.1 The Redistribution Model:

There are three aspects of the redistribution model which are considered:

(a) the implanted profile, (b) the oxidation model, and (c) the diffusivity model.

(a) The Implanted profile.

The implanted profile is described by the gaussian function,

$$C(y) = C_{\max} \exp \left\{ -\frac{1}{2} \left(\frac{y - R_p}{\Delta R_p} \right)^2 \right\}, \quad (3.1)$$

where C is the concentration, y is the distance from the entrant silicon surface, R_p is the range and ΔR_p is the straggle for the implant. The peak concentration, C_{\max} , is related to the implant dose, Q_{imp} by:

$$C_{\max} = Q_{\text{imp}} / \sqrt{2\pi} \Delta R_p. \quad (3.2)$$

Redistribution data has been generated for the following conditions:⁴

| | | |
|--------------------|---|--|
| Q_{imp} : | 5×10^{12} , 10^{13} , 5×10^{13} , 10^{14} | cm^{-2} |
| R_p : | 0.2735 μm 0.1727 " | 80 keV boron implant. 150 keV phosphorus. |
| ΔR_p : | 0.0665 μm 0.0440 " | 80 keV boron implant. 150 keV phosphorus. |

The doses are light to moderate resulting in concentrations no heavier than $6 \times 10^{18} \text{ cm}^{-3}$, and the range-straggle values are typical of those employed at MSFC. It is assumed that all of the ions become activated shortly after redistribution begins and thereby diffuse by a substitutional mechanism involving vacancies.

(b) Oxidation model:

The oxidation model is assumed to be the same as for bulk silicon and the data of Deal et. al.⁵ has been used to calculate the oxidation rate according to:

$$\frac{dx_o}{dt} = B / (2x_o + B/C), \quad (3.3)$$

where B and C follow Boltzmann-like temperature dependences. Figures (3.1) and (3.2) illustrate the oxide thickness dependence upon time and temperature for both dry O_2 and steam ambients.

During the oxidation, the silicon film thickness is reduced according to:

$$W = W_o - \alpha x_o, \quad (3.4)$$

where W_o is the initial film thickness, taken to be $1 \text{ } \mu\text{m}$, and $\alpha = 0.45$ is the ratio of the densities of SiO_2 to silicon. Redistribution data is given for $W_o = 1 \text{ } \mu\text{m}$ and an initial oxide thickness of $x_o = 300 \text{ } \text{\AA}$.

(c) Diffusivity model:

The diffusivity model for boron was discussed in an earlier report⁶ and it includes a linear dependence of the diffusivity upon the vacancy concentration as well as the field-enhancement effect. The diffusivity model for phosphorus includes only the field-enhancement effect which is sufficient to describe the non-linear behavior of phosphorus diffusions at concentrations lower than 10^{19} cm^{-3} as shown by Barry⁷ and Fair and Tsai⁸. The diffusivity-

temperature dependence is after Fair⁹ and Fair and Tsai⁸ adaptation of data by Ghostagore¹⁰. For either boron or phosphorous the effective diffusivity is given by:

$$D_{eff} = D(u) \times (1 + u / \sqrt{u^2 + 1}) , \quad (3.4)$$

where,

$$u = C / 2 n_i , \quad (3.5)$$

and,

$$\begin{aligned} D(u) &= D_B^* u, \quad \text{for boron,} \\ &= D_P^* , \quad \text{for phosphorus.} \end{aligned} \quad (3.6)$$

and where n_i is the intrinsic carrier concentration at the diffusion temperature and D_B^* and D_P^* are the intrinsic diffusivities of boron and phosphorus:

$$\begin{aligned} D_B^* &= 3.17 \exp (-3.59\text{eV} / k_B T) \text{ cm}^2/\text{sec.} , \\ D_P^* &= 3.85 \exp (-3.66\text{eV} / k_B T) \end{aligned} \quad (3.7)$$

3.2 Further Program Development:

The program which was used to generate the data has been described in detail in an earlier report. It was noted that the program was developed in such a way that one could take advantage of a normalization procedure for predeposition diffusions and generate data applicable to different film thicknesses. However, it is not possible to gain such an advantage for redistribution diffusions involving ion-implants or growth of an oxide. Then the program was used to generate data, it was discovered that some other features of the program are extraneous unless further refined.

The program was developed to account for both thin and thick oxides such as would be encountered in some practical situations. However, such a simulation requires the incorporation of a warped grid system, a modification which would require considerably more effort. Therefore, the variable oxide feature

is of limited value at this time, since the program, at best, only approximates the conditions for growth of a very thin oxide during redistribution.

A modification was made which allows accurate treatment of redistribution under oxidizing conditions when only a single oxide thickness is involved. The original program treated the oxidation process with regard to the boundary conditions; however, unlike the case of bulk silicon, one must also account for the reduction of the silicon film thickness. This feature is now included in the program. During the simulation of a redistribution in an oxidizing ambient, the vertical grid spacing continuously shrinks while the horizontal grid spacing is constant. The modification does not show up on logic flow diagrams at the level of detail which has previously been given. For completeness, a new listing of the affected main and sub-programs is given in the appendix.

3.3 Computational Procedure:

The program described in an earlier report, and modified as described in the preceding, was used to generate the data. Two-dimensional data was obtained in the form of isoconcentration contours for typical situations. The bulk of the data which can be correlated with experimental measurements is generated using a quasi-one-dimensional model in a manner described in a previous report.⁶ A brief review of the procedure is given in the following.

For generation of sheet resistance, junction depth and integrated impurity dose data as a function of time and temperature, only a one-dimensional profile need be calculated. This is accomplished by making the horizontal grid only three units wide but keeping the field six film thicknesses wide. Periodic boundary conditions for the horizontal dimensions are employed in the program and result in a calculation which produces the vertical profile

equivalent to a none-dimensional model. Thus without sacrificing the generality of the program for treating two-dimensional cases, the amount of computing time is drastically reduced when the data that is desired does not require the full power of the program.

The vertical grid varies from thirty one to sixty one points as required for accuracy in details of the profile, and most of the data is not sensitive to the number of grid points used if the number is chosen in this range. For the purpose of illustrating the unusual nature of phosphorous profiles, the larger number of points was required.

3.4 Discussion of Results:

First, some of the unusual behavior of redistribution diffusions in SOS films will be discussed in this section. Next, the format for the calculated curves will be discussed, and, finally, the bulk of the generated data is given in the appendix without further comment.

Figures (3.1) and (3.2) illustrate the oxide thickness growth and silicon film thickness reduction as functions of time for $\langle 111 \rangle$ silicon films oxidized in steam and dry O_2 ambients. The evolution traced beginning with an initial oxide of 300 Å thickness on an SOS film of 1 μm initial thickness. The curves are shown for four temperatures. The data are necessary for interpreting some of the results for simulated redistributions.

Figures (3.3) and (3.4) show impurity profiles for boron and phosphorus implants being redistributed in a steam ambient at 1000 deg. C. The profiles are all plotted with a common origin as would be the case for experimentally derived profiles where the Si-SiO₂ interface would serve as the logical origin. However, the profiles are normalized with respect to the film thickness which

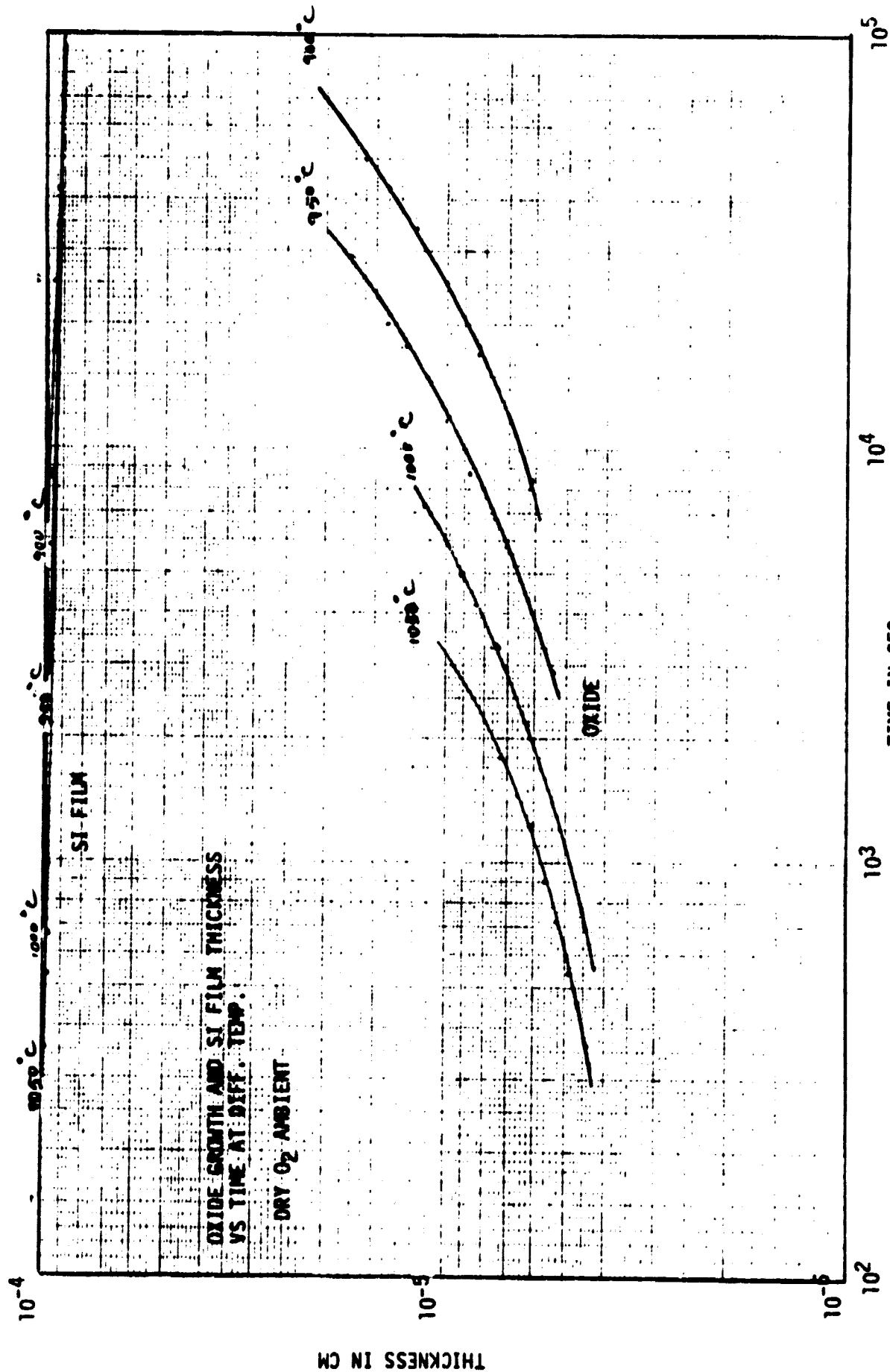


Figure 3.1

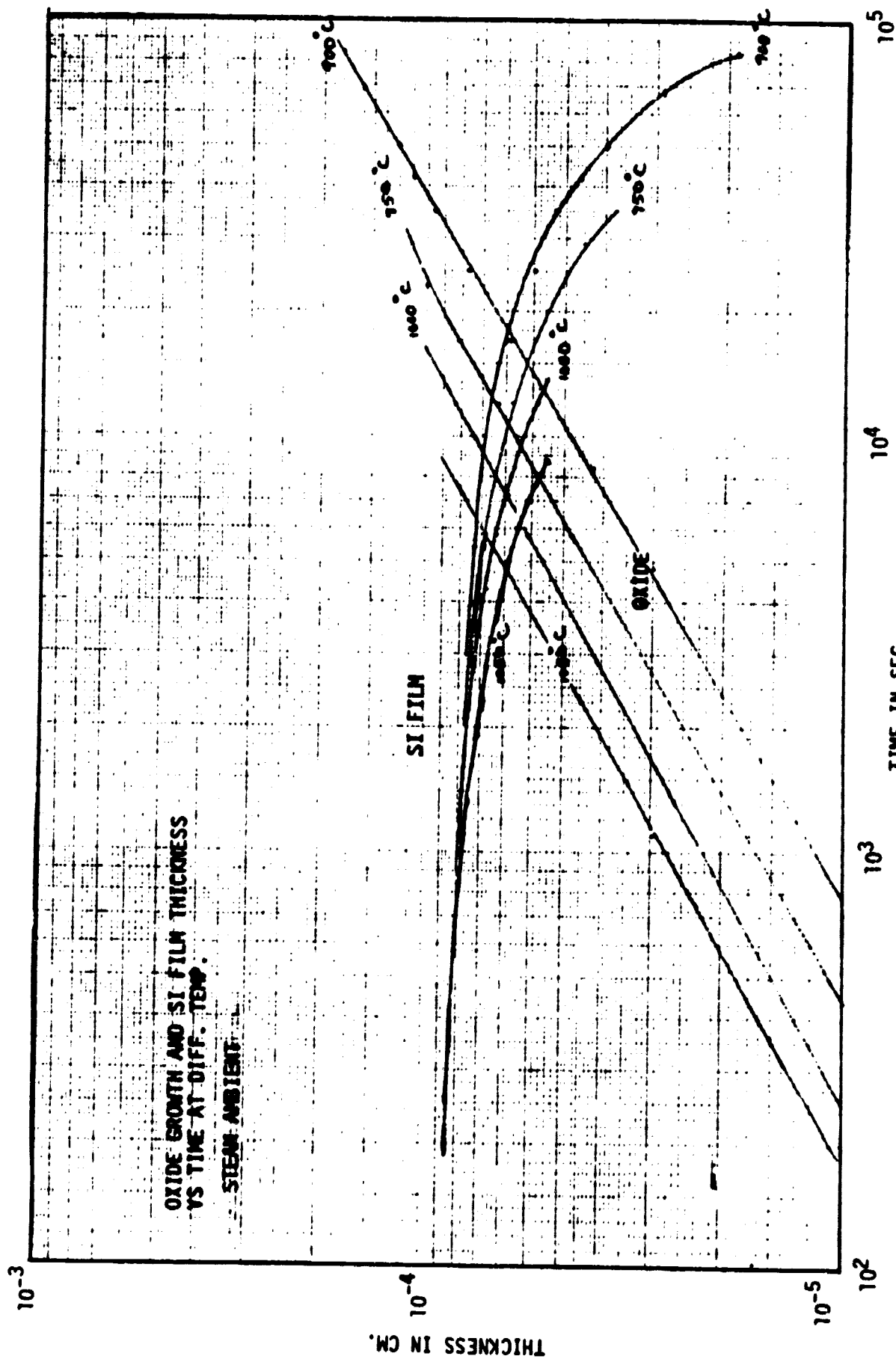
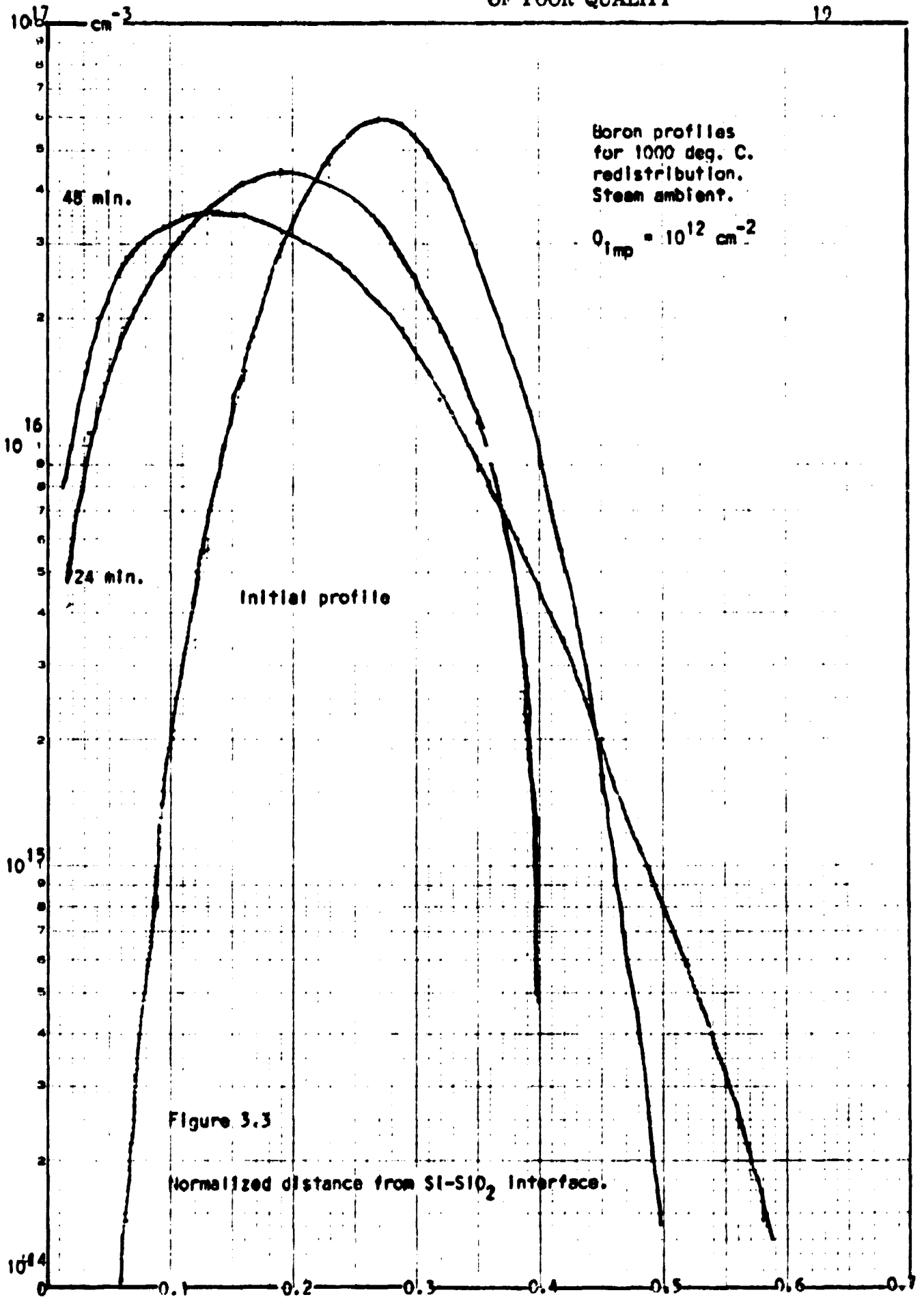


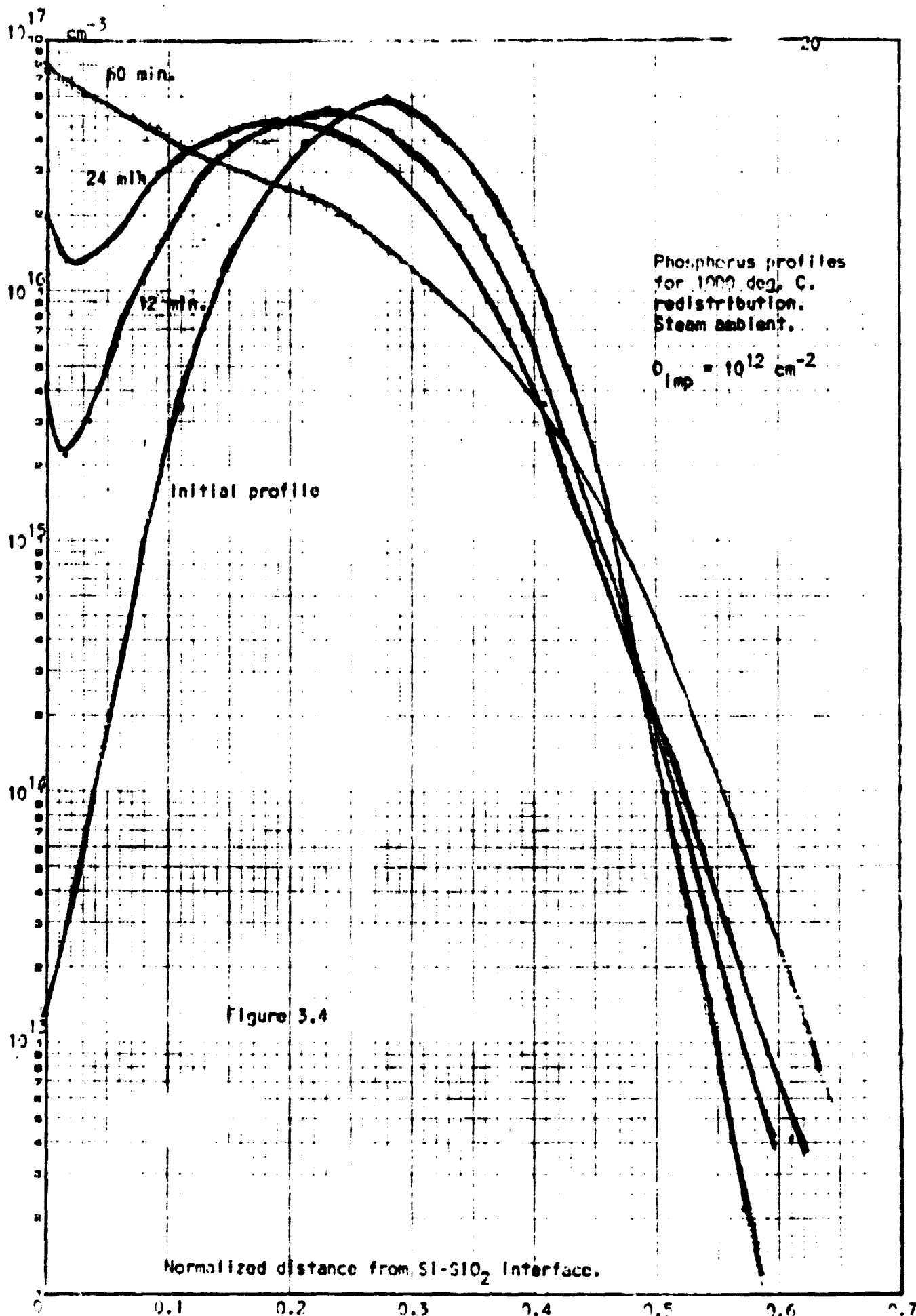
Figure 3.2

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MADE IN U.S.A.
3400-13-0 DIETZEN GRAPH PAPER
SEMI-LOGARITHMIC
3 CYCLES X 10 DIVISIONS PER INCH



DIETZGEN CORPORATION
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NO. 340R-LS10 DIETZGEN GRAPH PAPER
SEMI-LOGARITHMIC
5 CYCLES X 10 DIVISIONS PER INCH



is of course shrinking. The boron profiles are not unusual but show the well-known leaching effect due to segregation into the oxide. The phosphorus profiles show the effect of impurities being rejected from the oxide. There is a pile-up of impurities in front of the advancing Si-SiO₂ interface and then a dip which eventually disappears. It is easy for one to draw an erroneous conclusion from observing the profiles, because it appears that the integrated dose should increase for at least remain constant and the sheet resistance should decrease with time. This is not true. Although the segregation coefficient favors phosphorus in silicon vs. SiO₂, eventually all of the phosphorus will be in the SiO₂ when the SOS film is completely oxidized since the model assumes that there is no diffusion into the sapphire.

Figures (3.5-3.7) illustrate the behavior of the junction migration, sheet resistance variation, and integrated impurity dose variation over a long period of time. All of the curves are plotted with respect to normalized time, and true time is obtained by multiplying by the normalizing time value given on the plot. Junction depths are in microns, sheet resistance values are in ohms, and dose values are in cm⁻² units unless otherwise marked. The curves are given in the typical format for all of the data.

For an ion-implanted profile, there are in fact two junctions until one of the junctions emerges at the Si-SiO₂ interface. Therefore, the sheet resistance values are for the buried layer until the front junction disappears. This typically occurs in a short time compared with that for through-diffusion of the back junction. Figure (3.5) illustrates the through-diffusion of the back junction for the heavier doses. This always occurs for redistribution in a nitrogen ambient but not necessarily so for an oxidizing ambient. After the through diffusion, or even before for light doses, the junction depth will eventually decrease due to the reduction of the film thickness or due to the

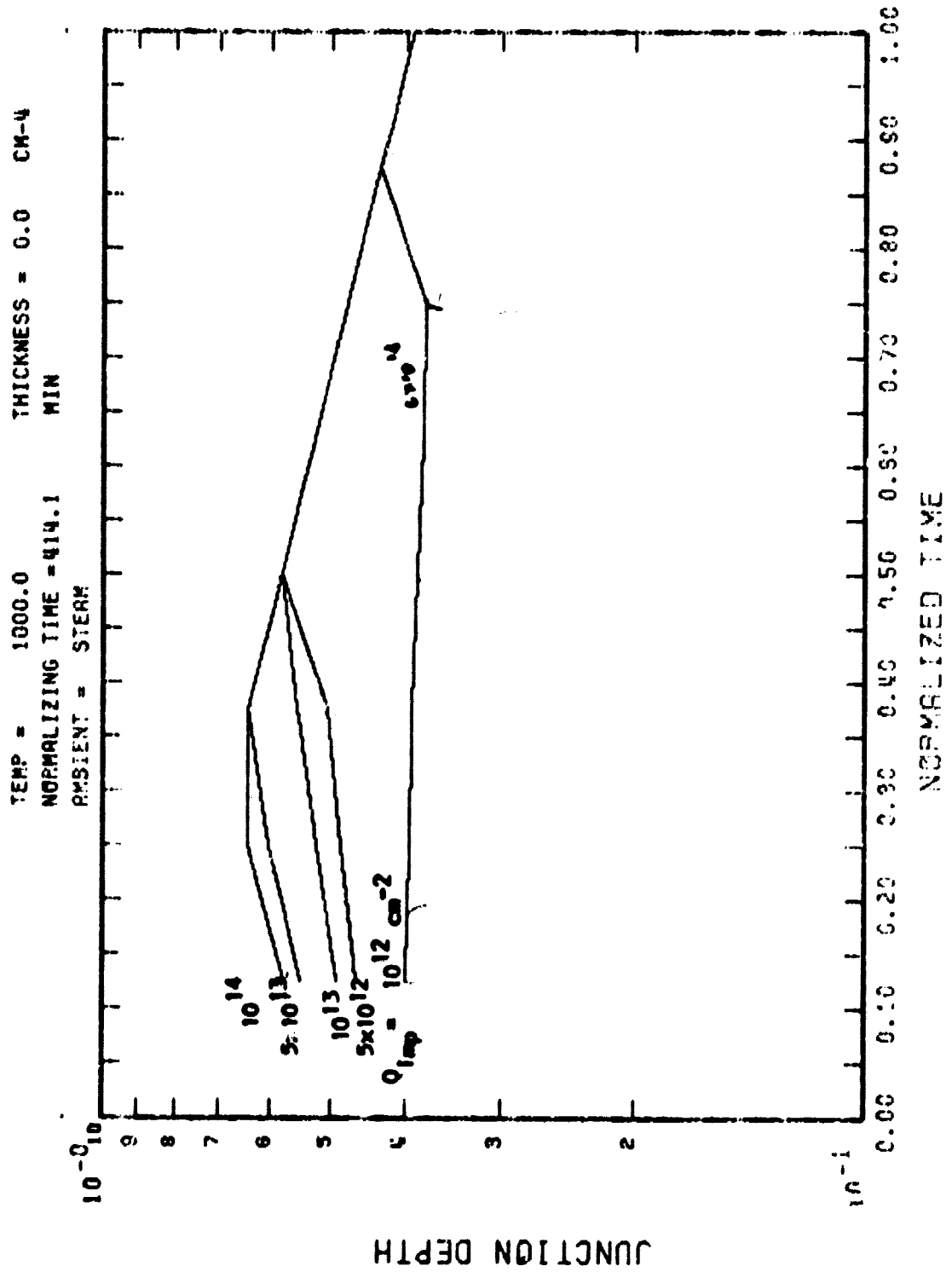


Figure 3.5 Junction position with respect to Si-SiO₂ interface for Boron redistribution.

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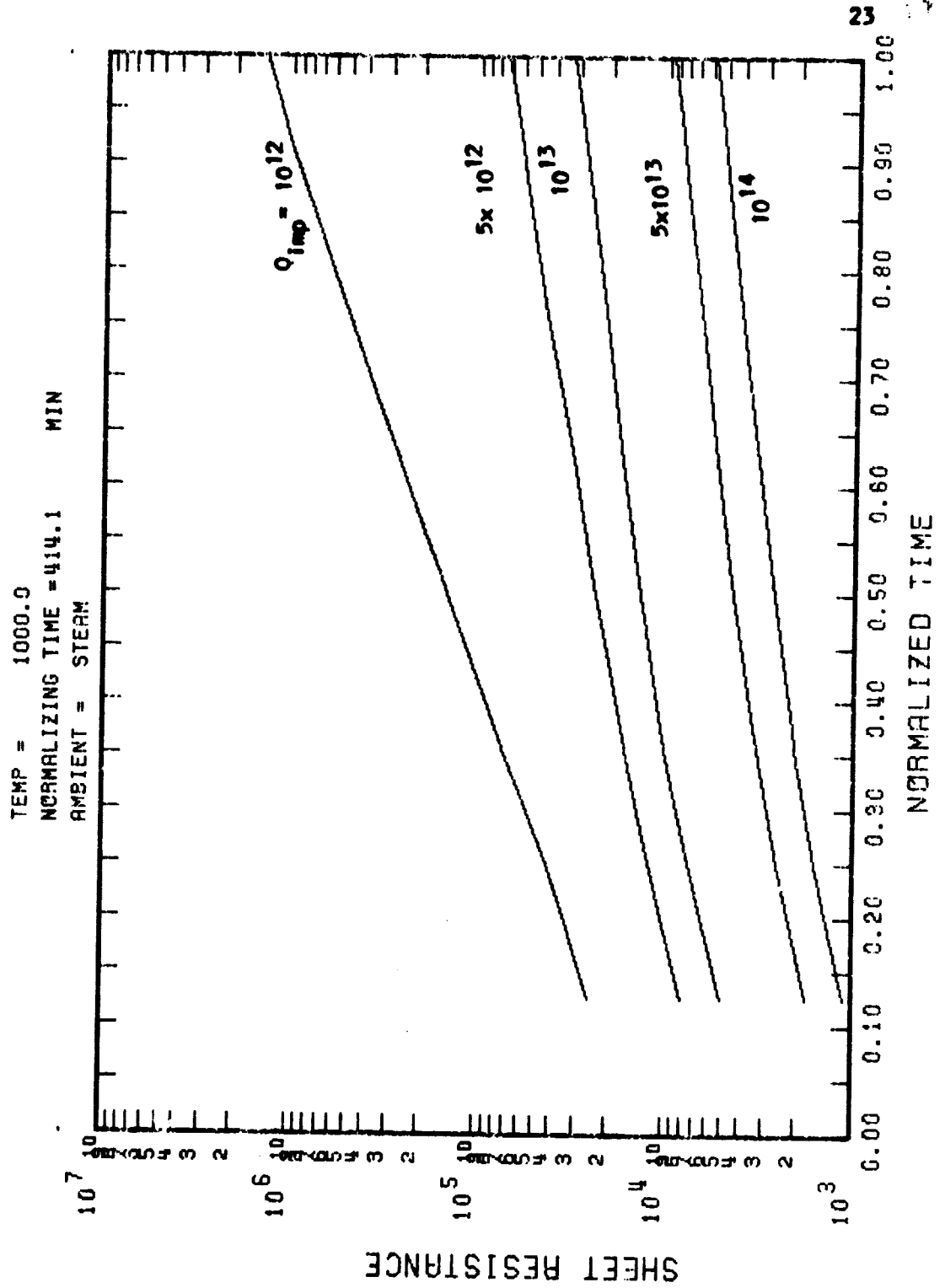


Figure 3.6 Sheet resistance for Boron redistribution.

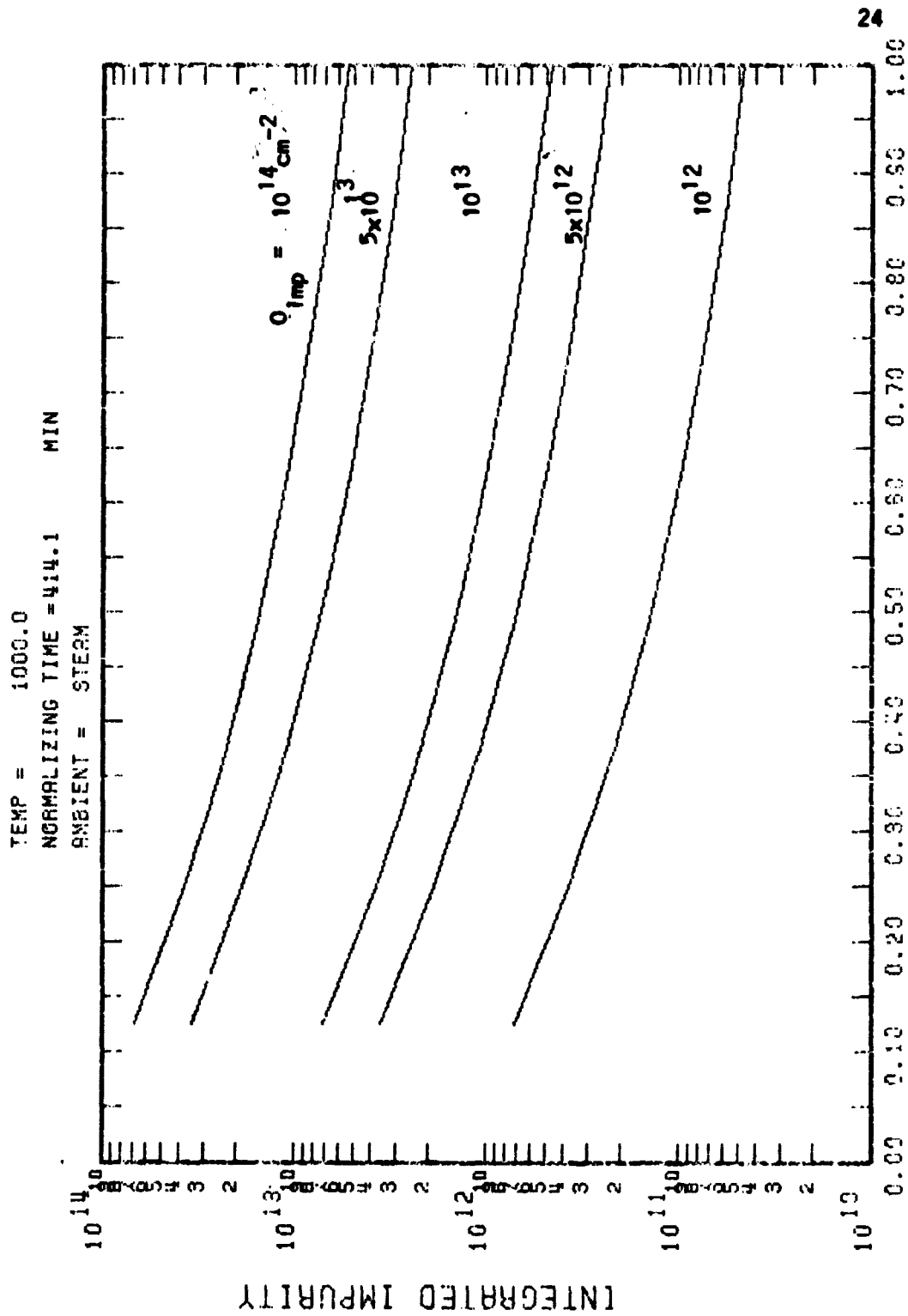


Figure 3.7 Variation of Dose for Boron redistribution.

relatively slow advancement of the junction with respect to the moving Si-SiO₂ interface. In some of the data presented in the appendix, the junction appears to remain almost stationary for this same reason. The variation of the sheet resistance and dose with redistribution time also may appear strange when compared with results for bulk silicon; however, consideration of the previously mentioned factors also explains these results.

Two-dimensional isoconcentration contours are given in the appendix for the various ambients and the two impurity types. The results are not as remarkable as those given in the last report which were for chemically pre-deposited boron. In that case, there was initially a heavy concentration of fast diffusing impurities at the Si-SiO₂ interface which were strongly retarded due to the segregation phenomena. This does not happen with the ion-implanted predeposit because the initial profile lies below the interface at which the segregation phenomena is effective.

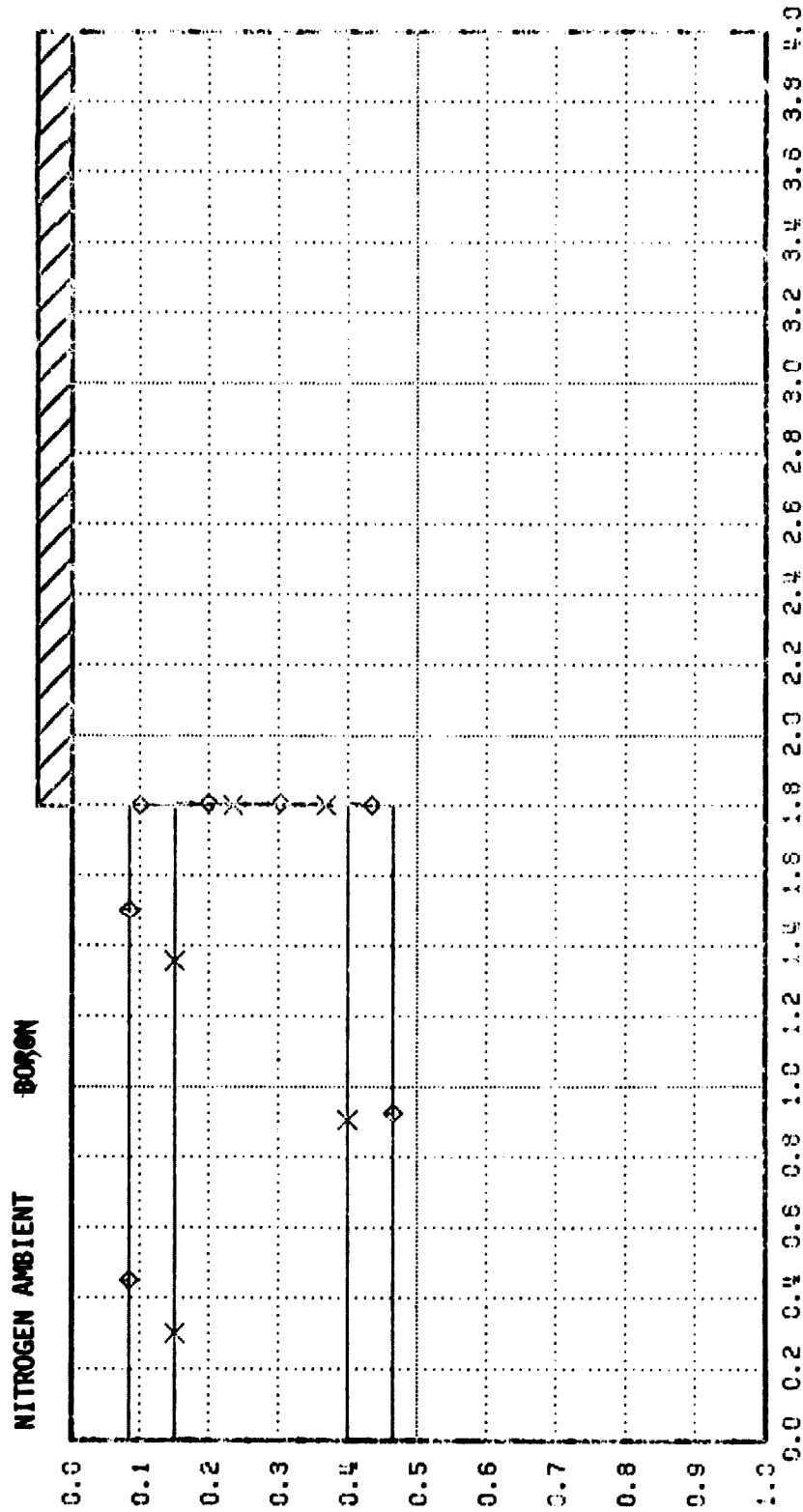
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APPENDIX

BORON DATA

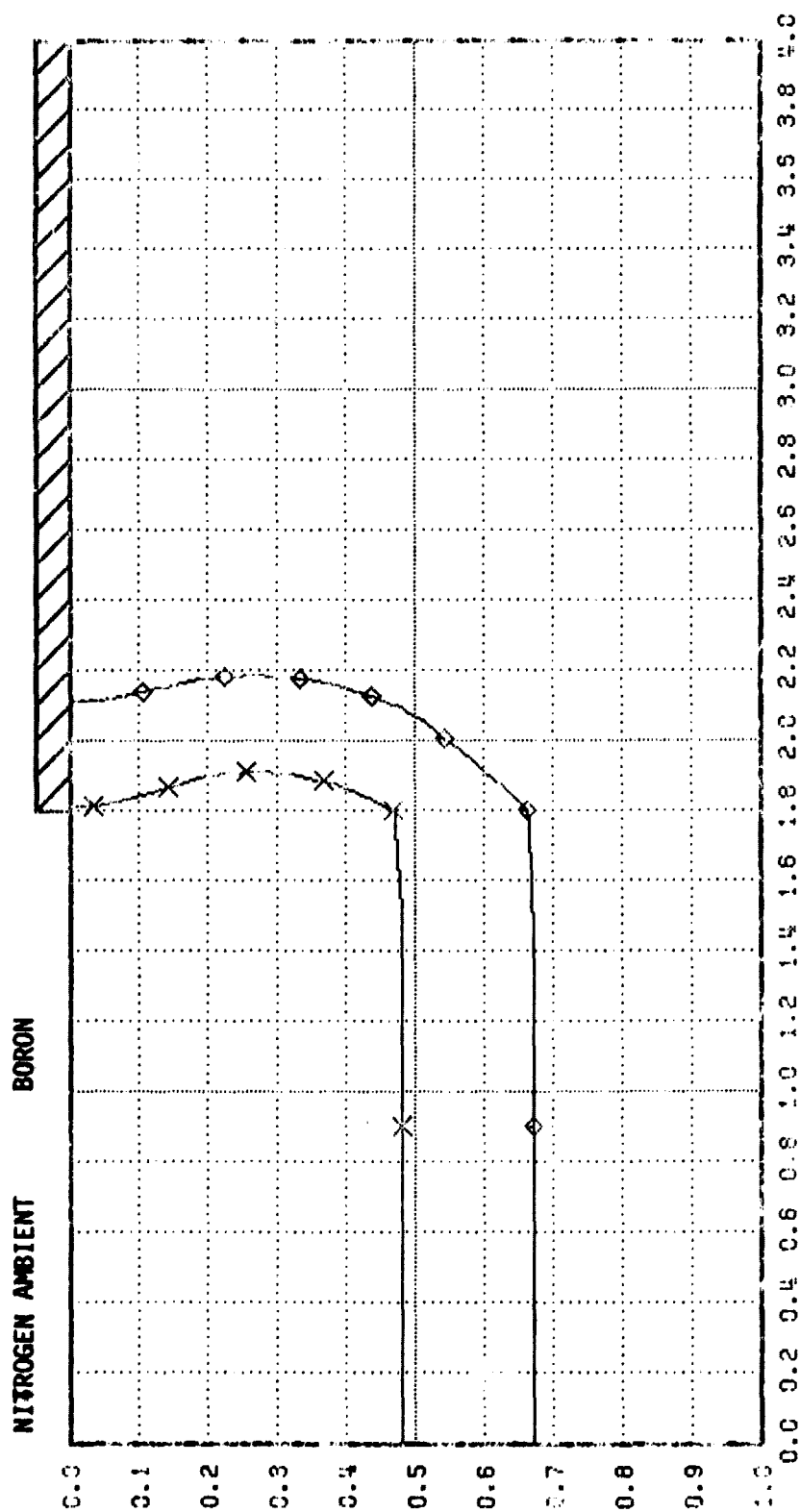
χ^2
 TEMPERATURE = 0.0480
 TIME STEP = 1000.
 TIME = 0.00
 1.0E20
 1.0E19
 1.0E18
 1.0E17
 1.0E16
 1.0E15



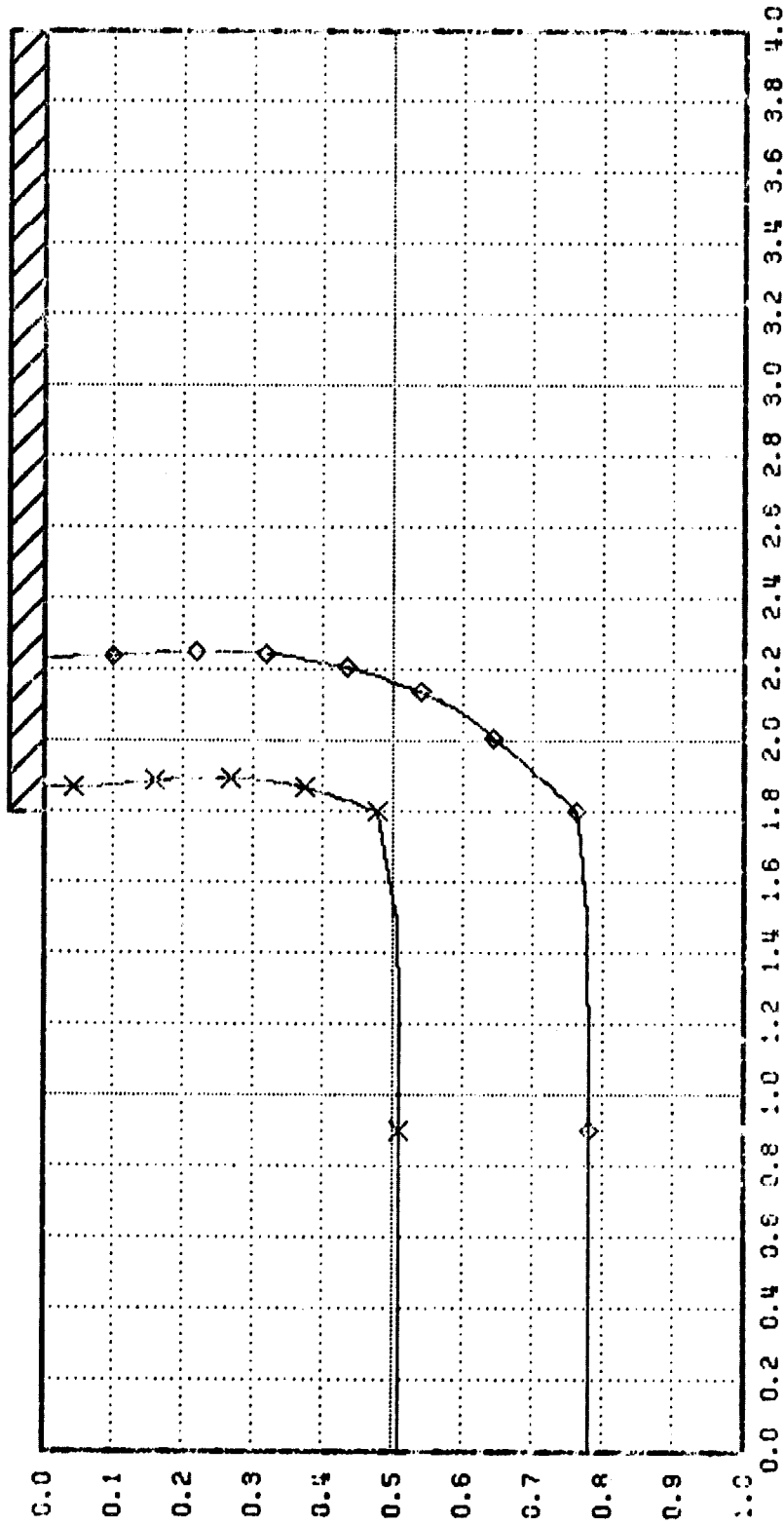
λ^2 = 0.0480
 TEMPERATURE = 1000.
 TIME STEP = 10
 TIME = 0.20

- 1.0E20
 - 1.0E19
 - 1.0E18
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 - 1.0E16
 - 1.0E15

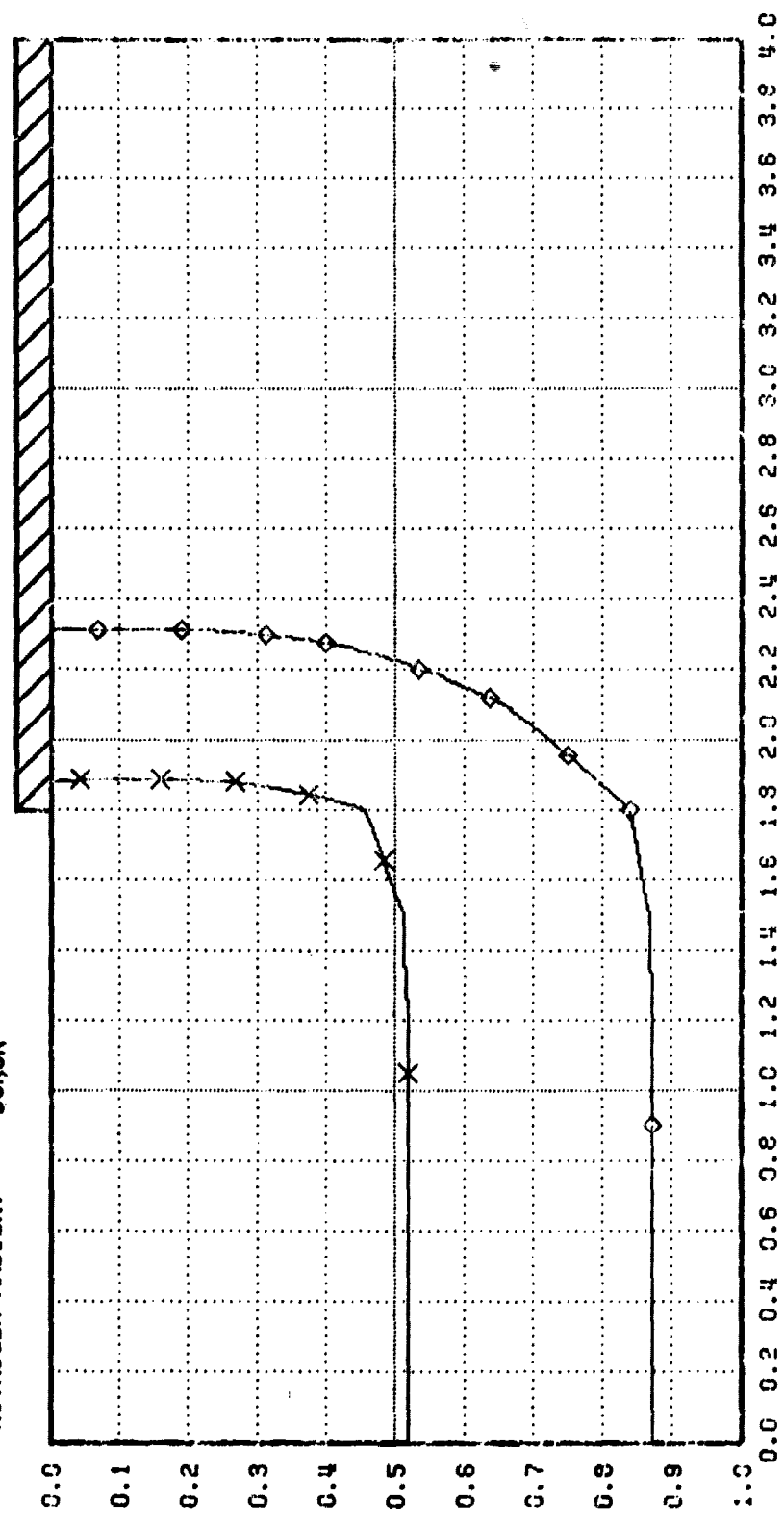
E O X + X O



χ^2
 TEMPERATURE = 0.0480
 TIME STEP = 1000.
 TIME = 20
 = 0.40
 NITROGEN AMBIENT BORON



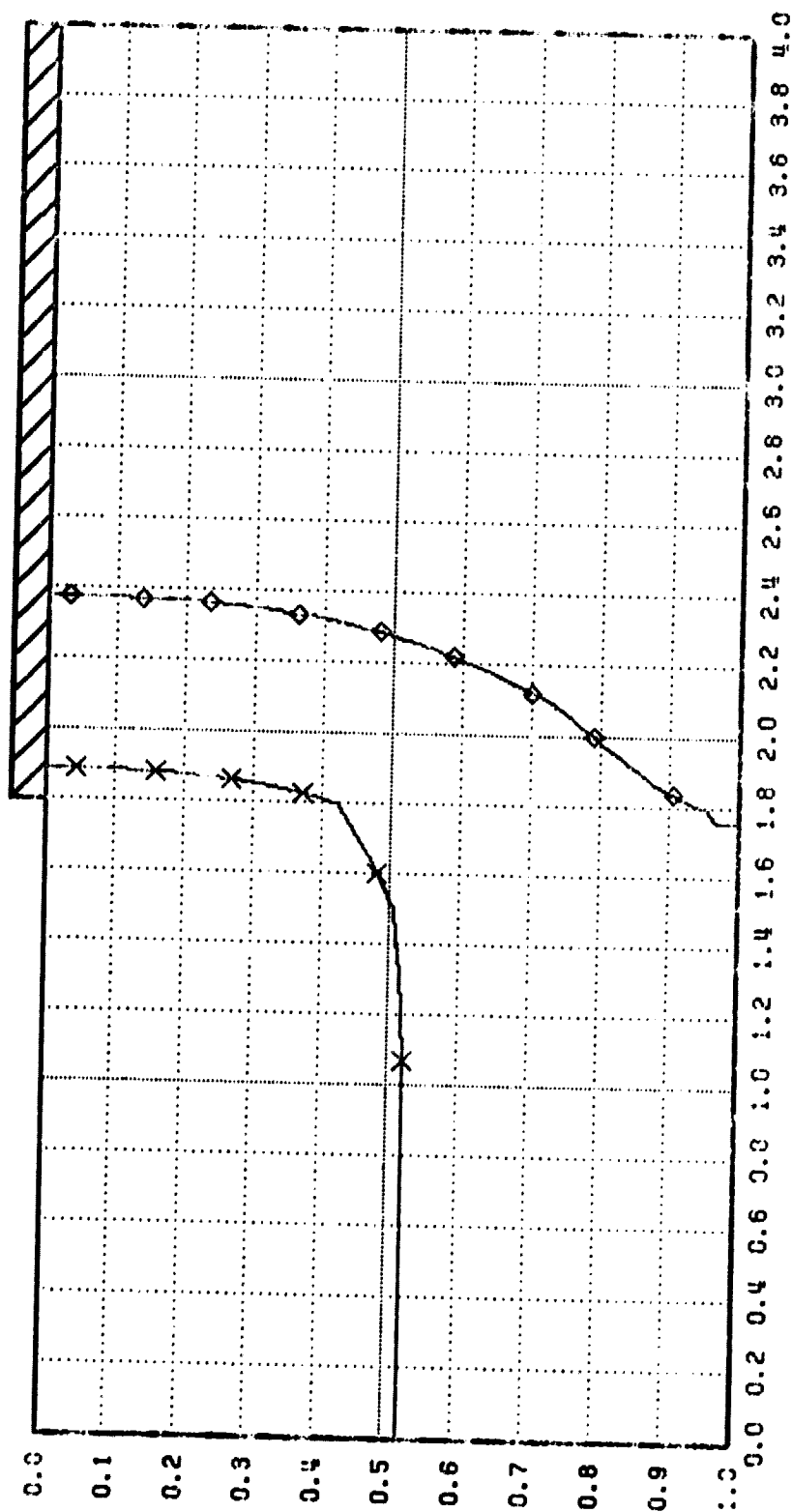
λ^2
 TEMPERATURE = 0.0480
 TIME STEP = 1000.
 TIME = 30
 = 0.60
 NITROGEN AMBIENT BORGON



λ^2
 TEMPERATURE = 0.0480
 TIME STEP = 1000.
 TIME = 40
 NITROGEN AMBIENT BORON = 0.80

- 1.0E20
 - 1.0E19
 - 1.0E18
 - 1.0E17
 - 1.0E16
 - 1.0E15

□ ○ ▲ + × ◇



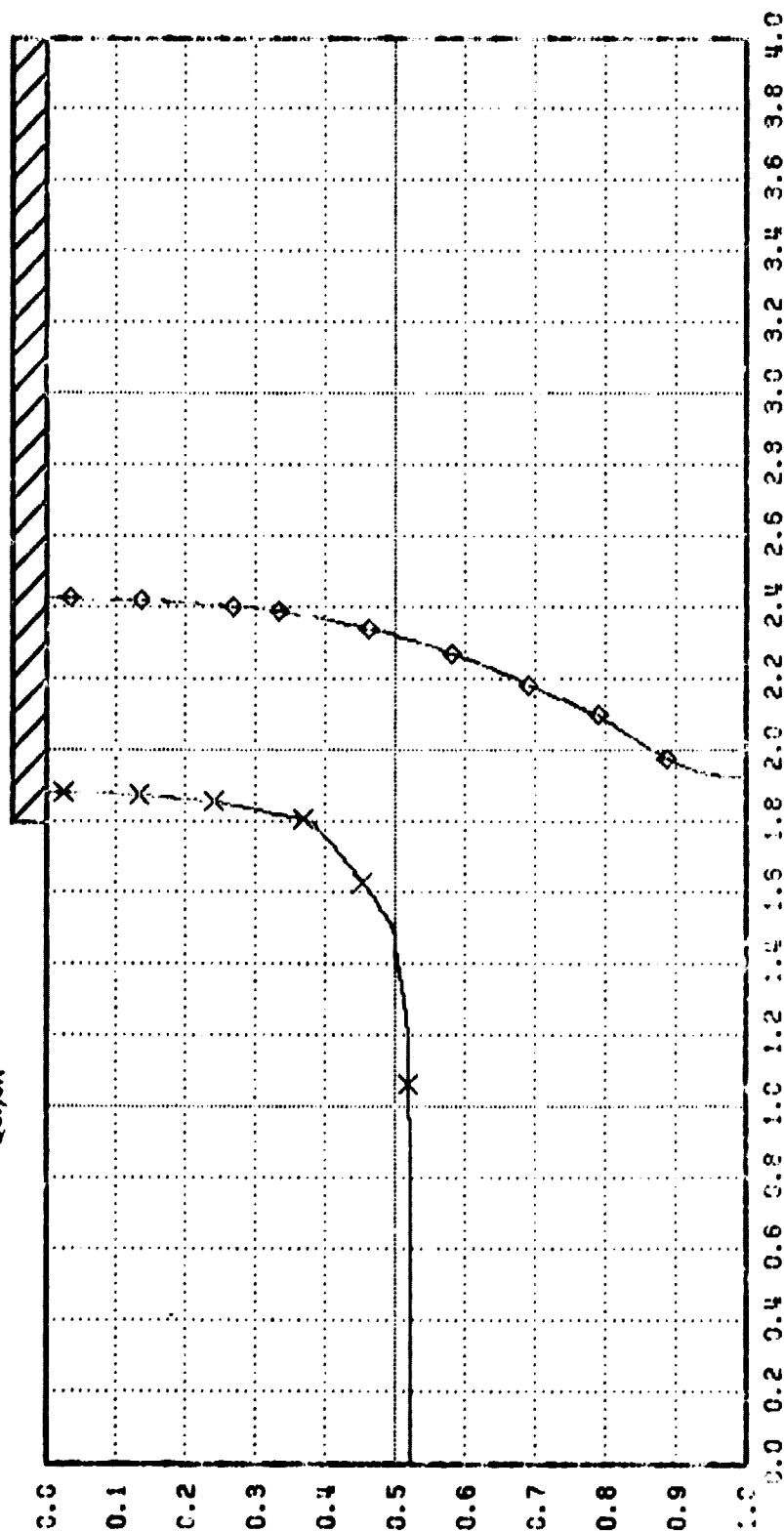
λ^2
 TEMPERATURE
 TIME STEP
 TIME

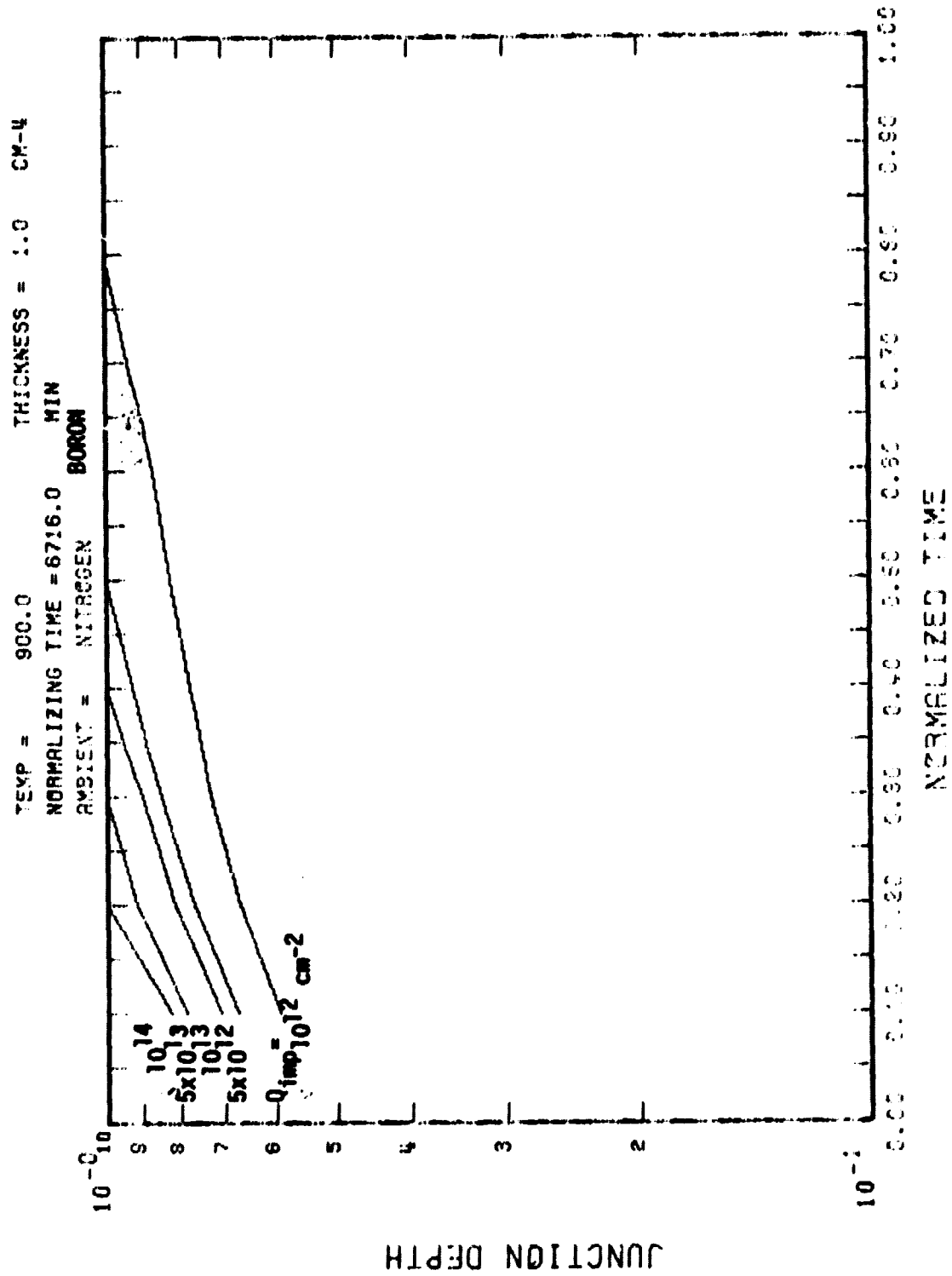
= 0.0480
 = 1000.
 = 50
 = 1.00

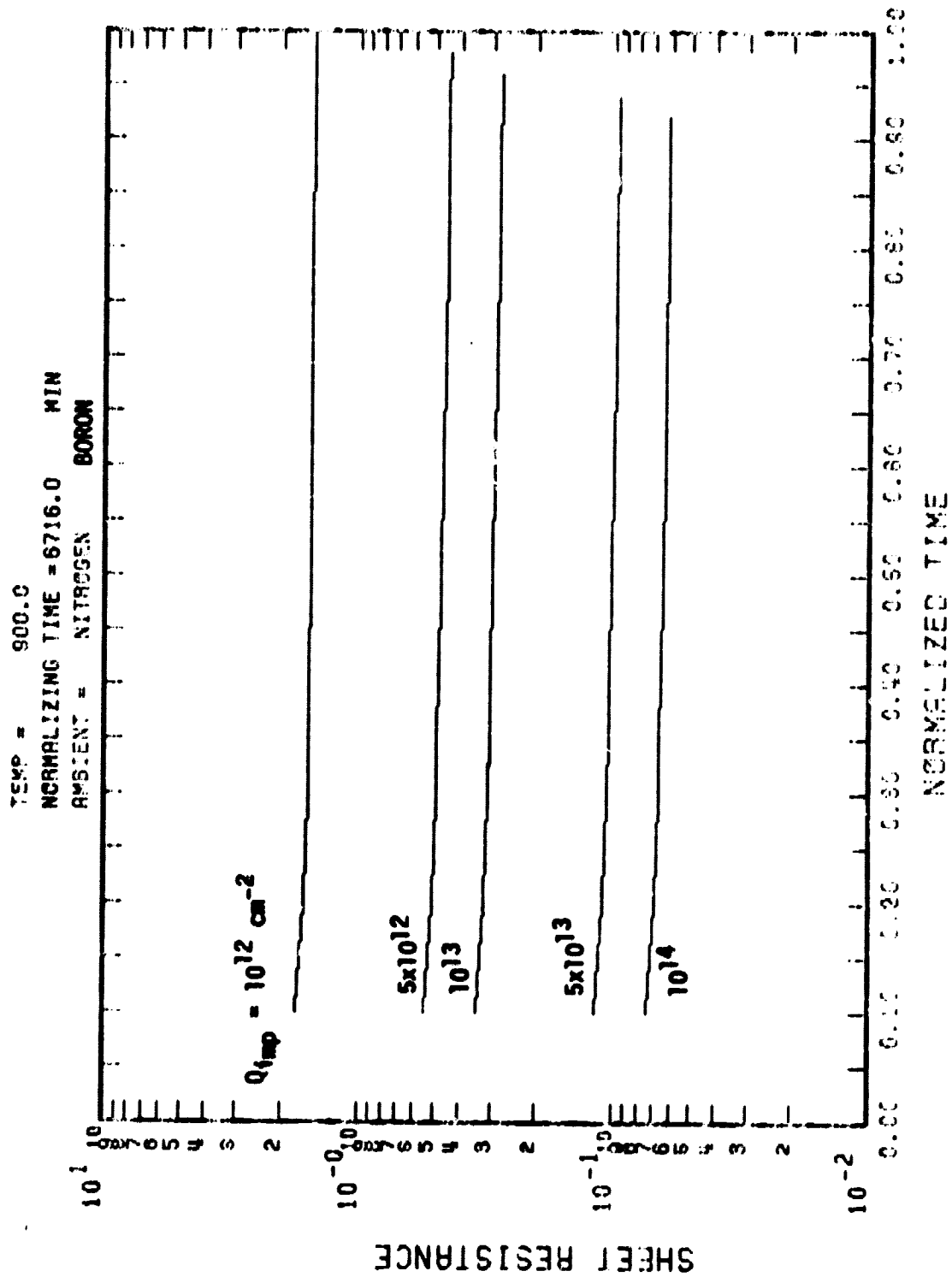
- 1.0E20
 - 1.0E19
 - 1.0E18
 - 1.0E17
 - 1.0E16
 - 1.0E15

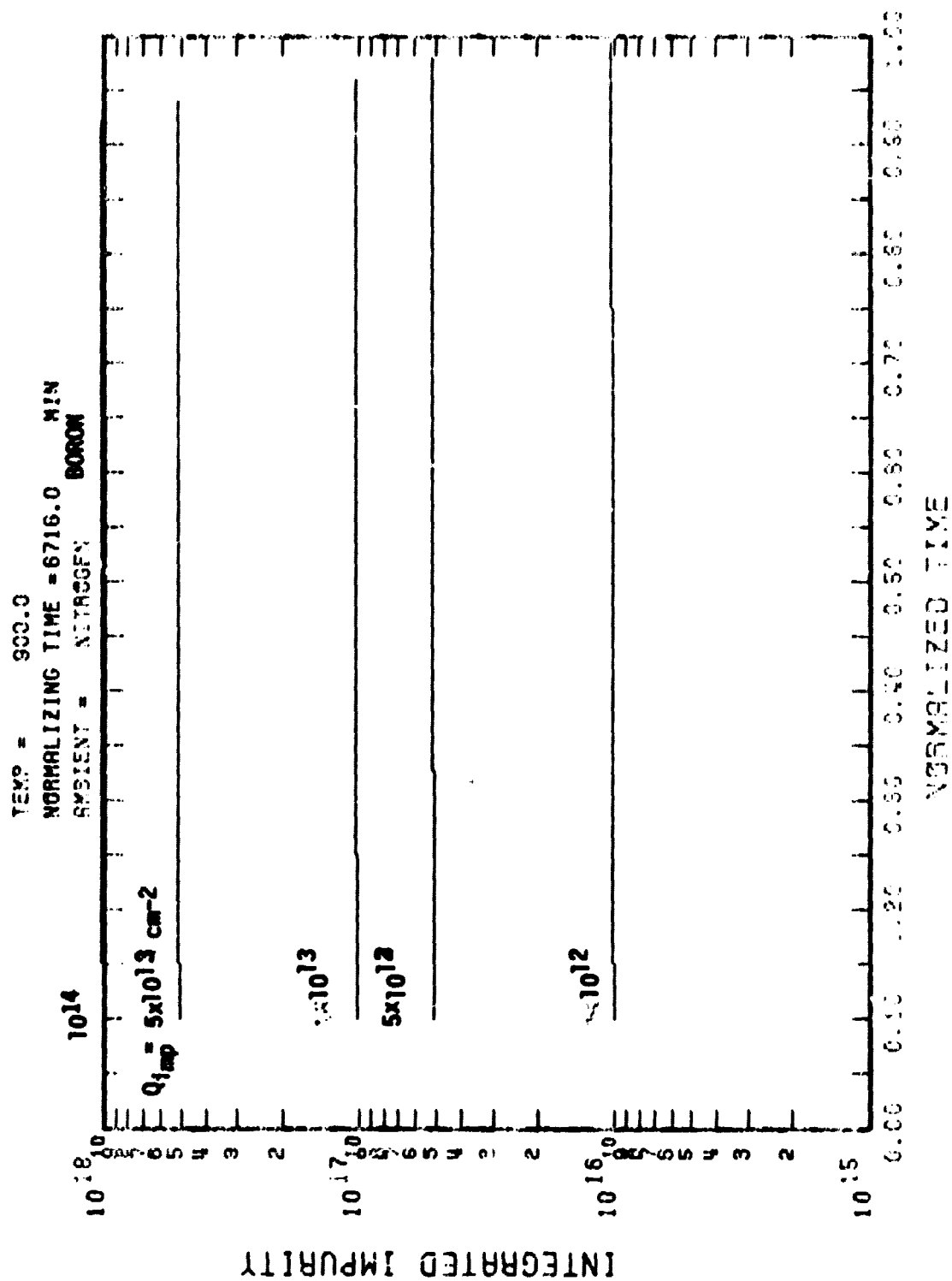
□ ○ △ + × ◇

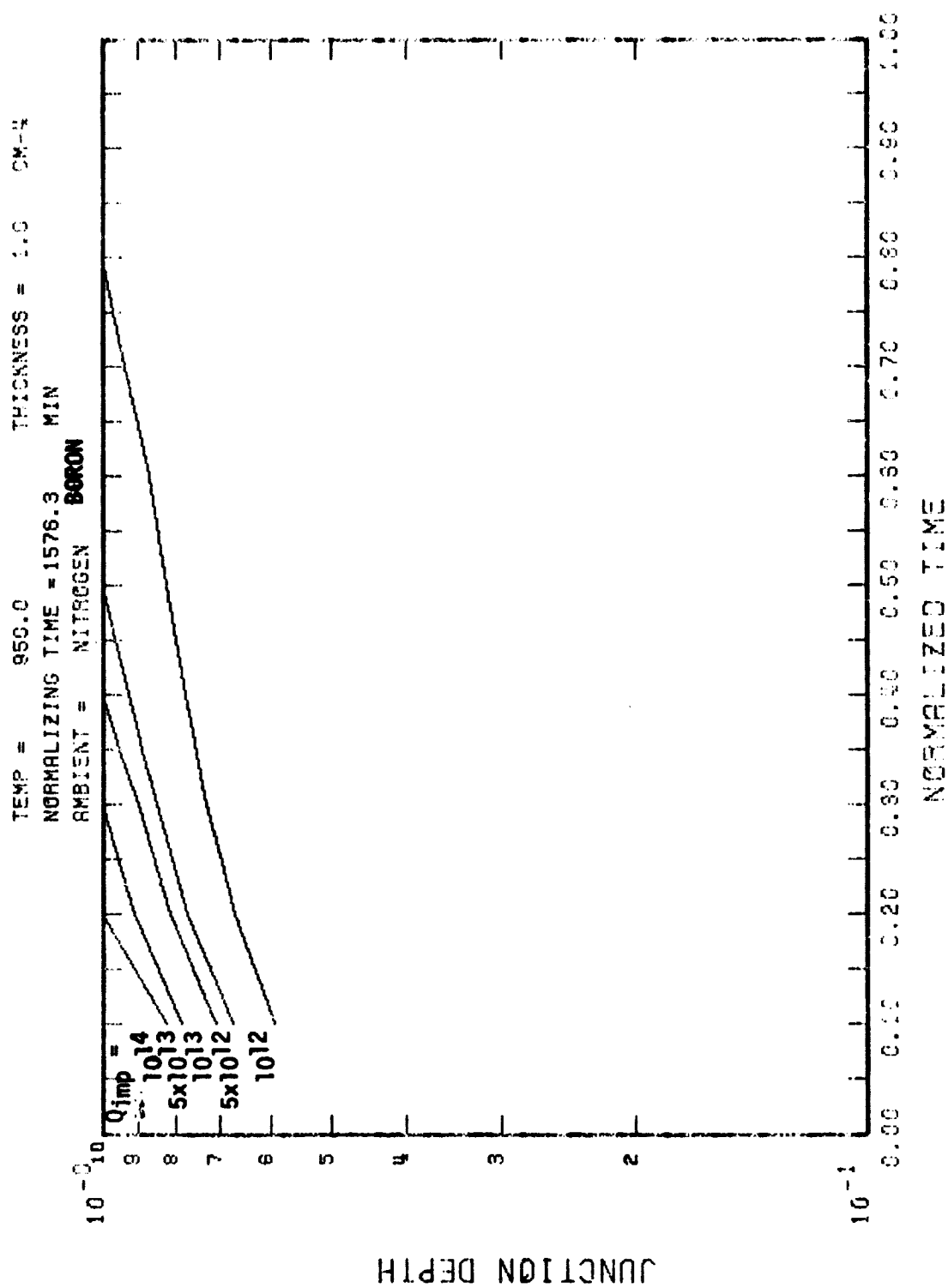
NITROGEN AMBIENT BORGON

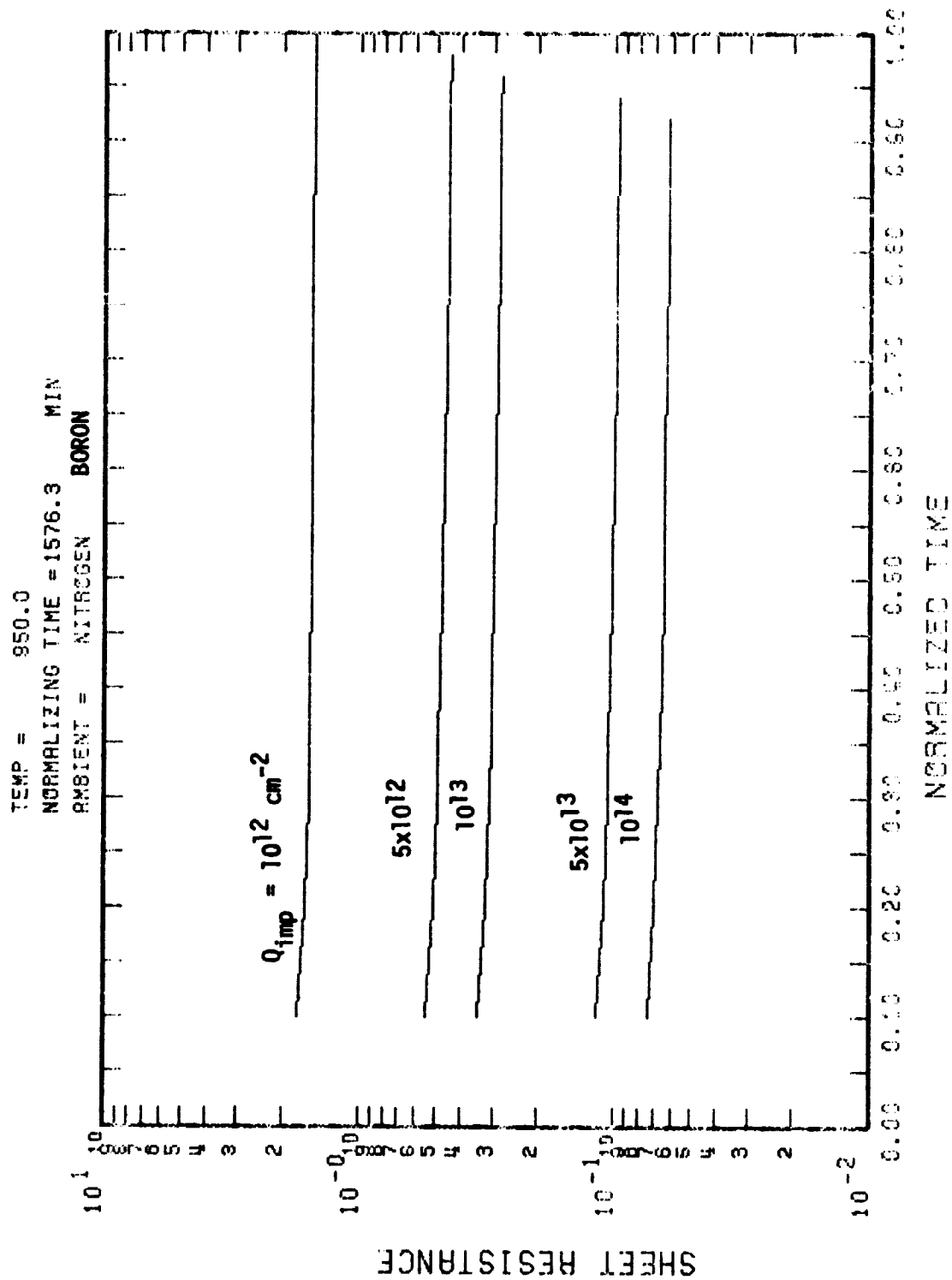


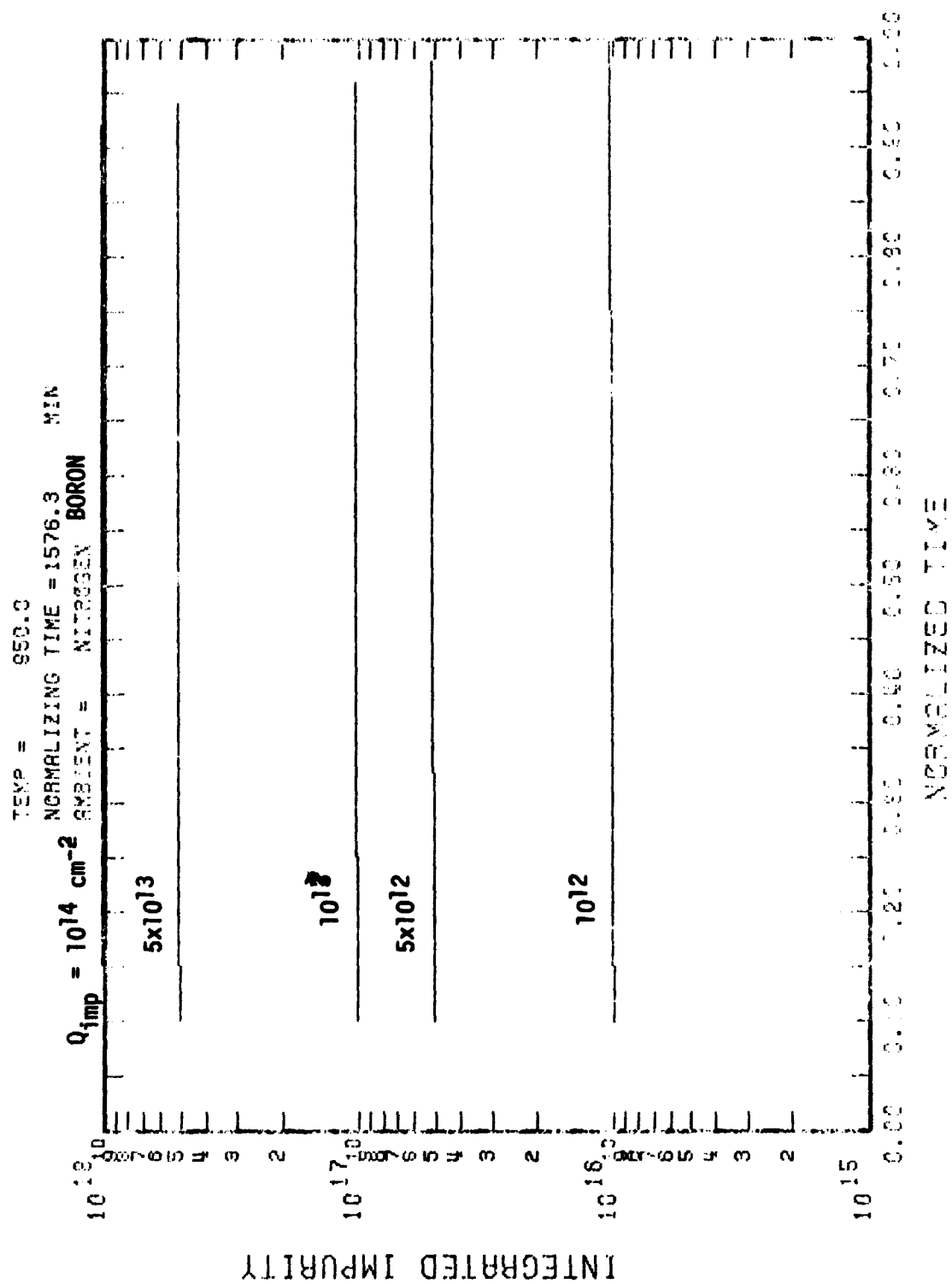


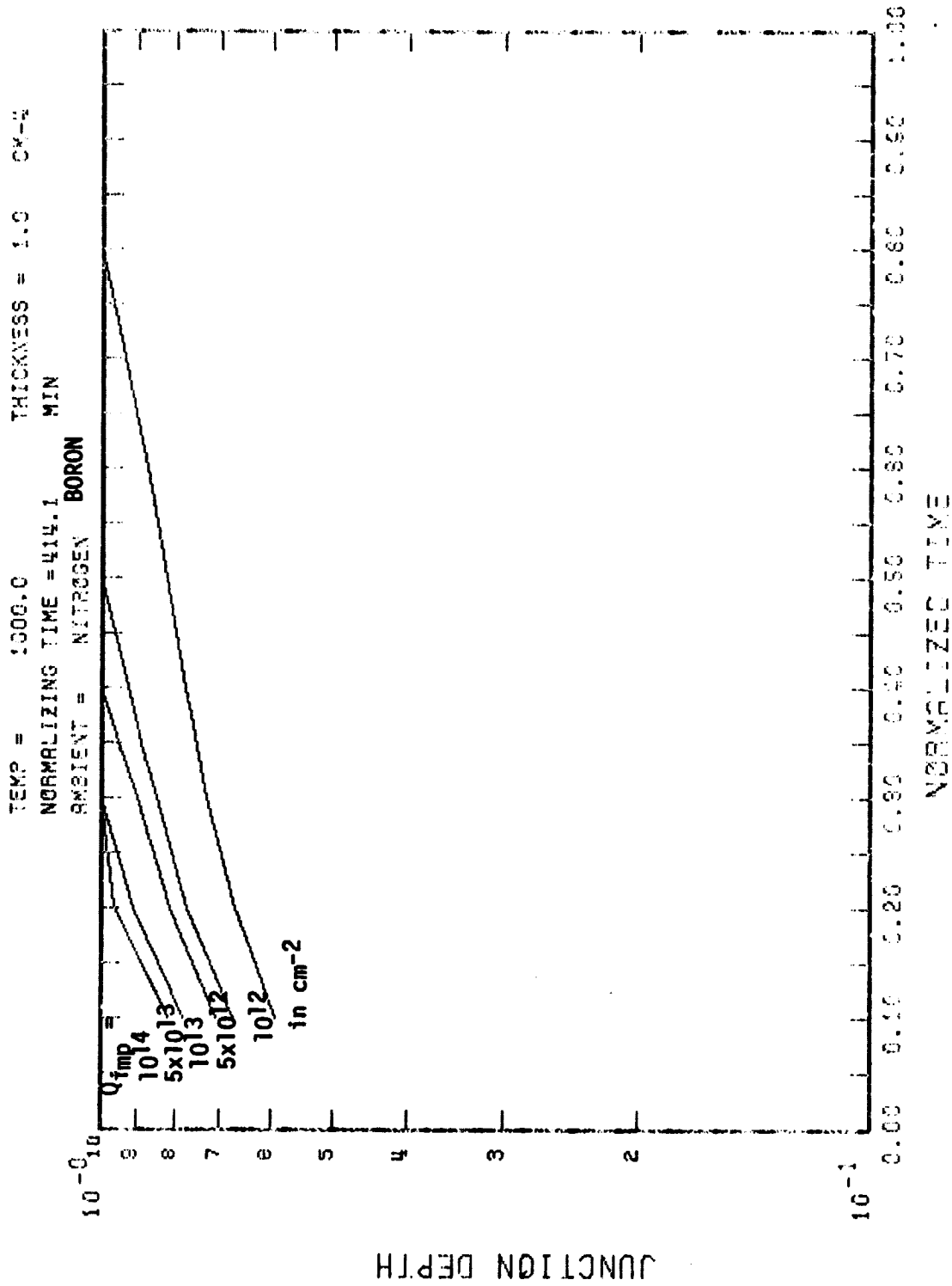


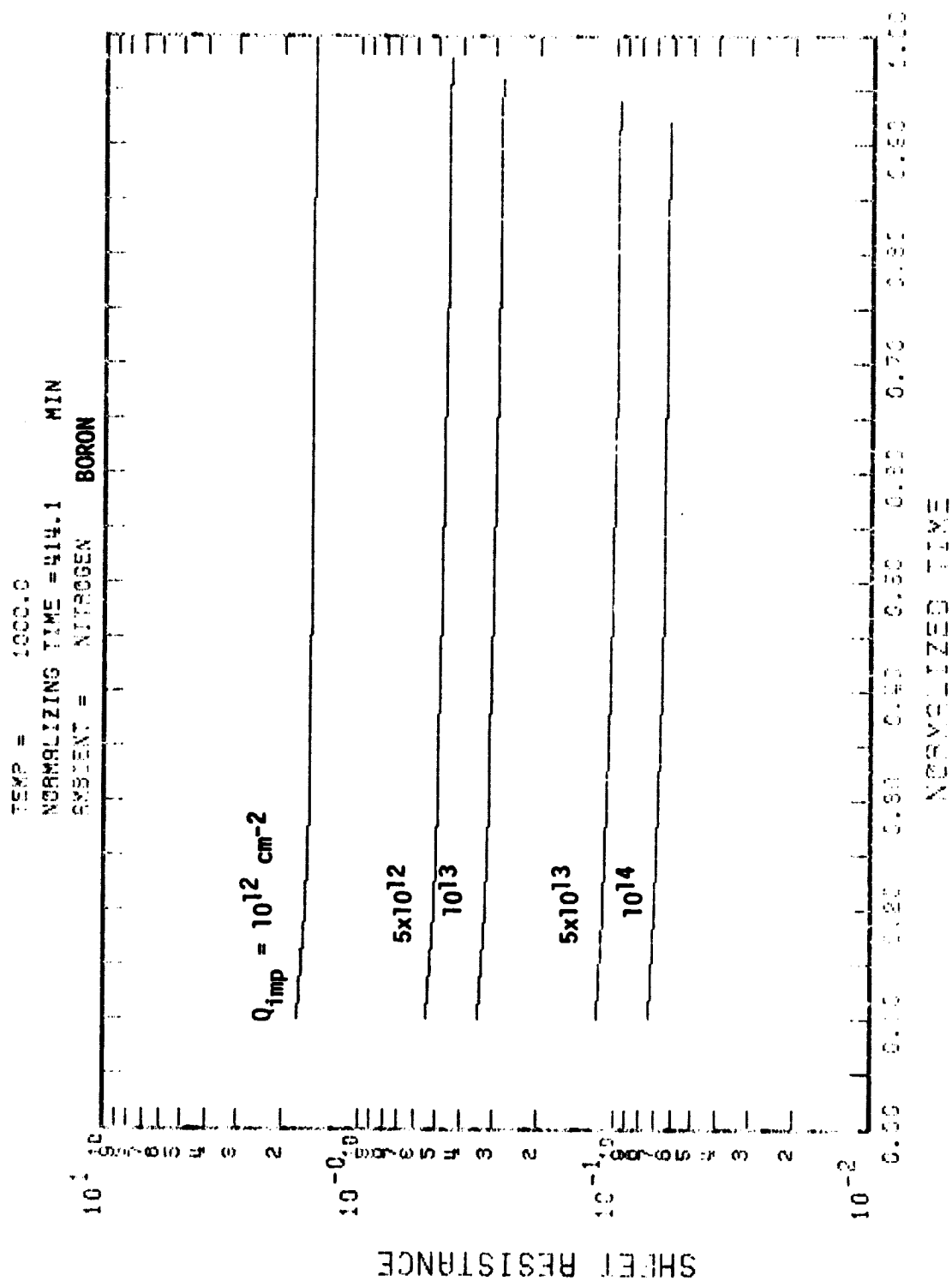


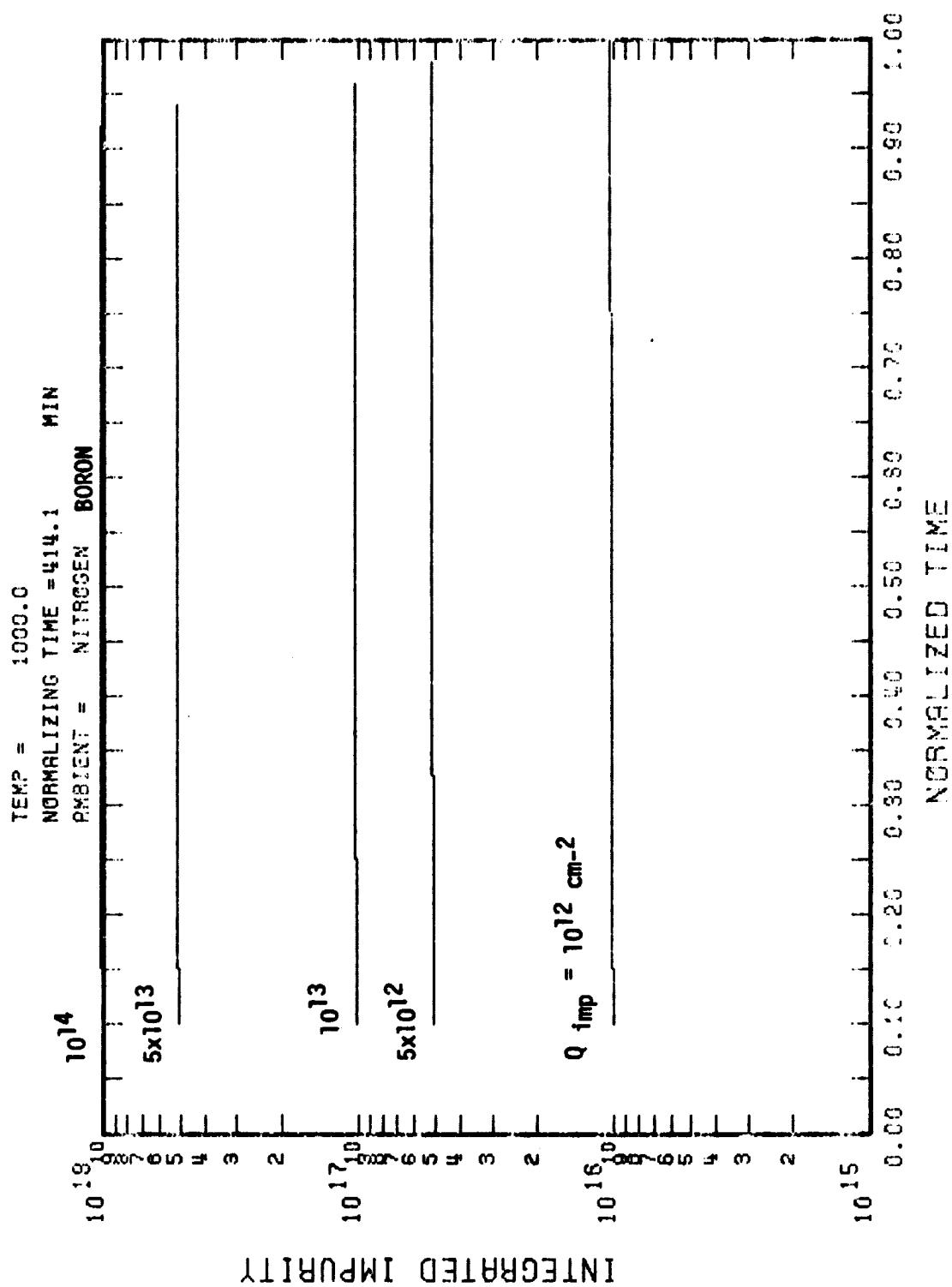


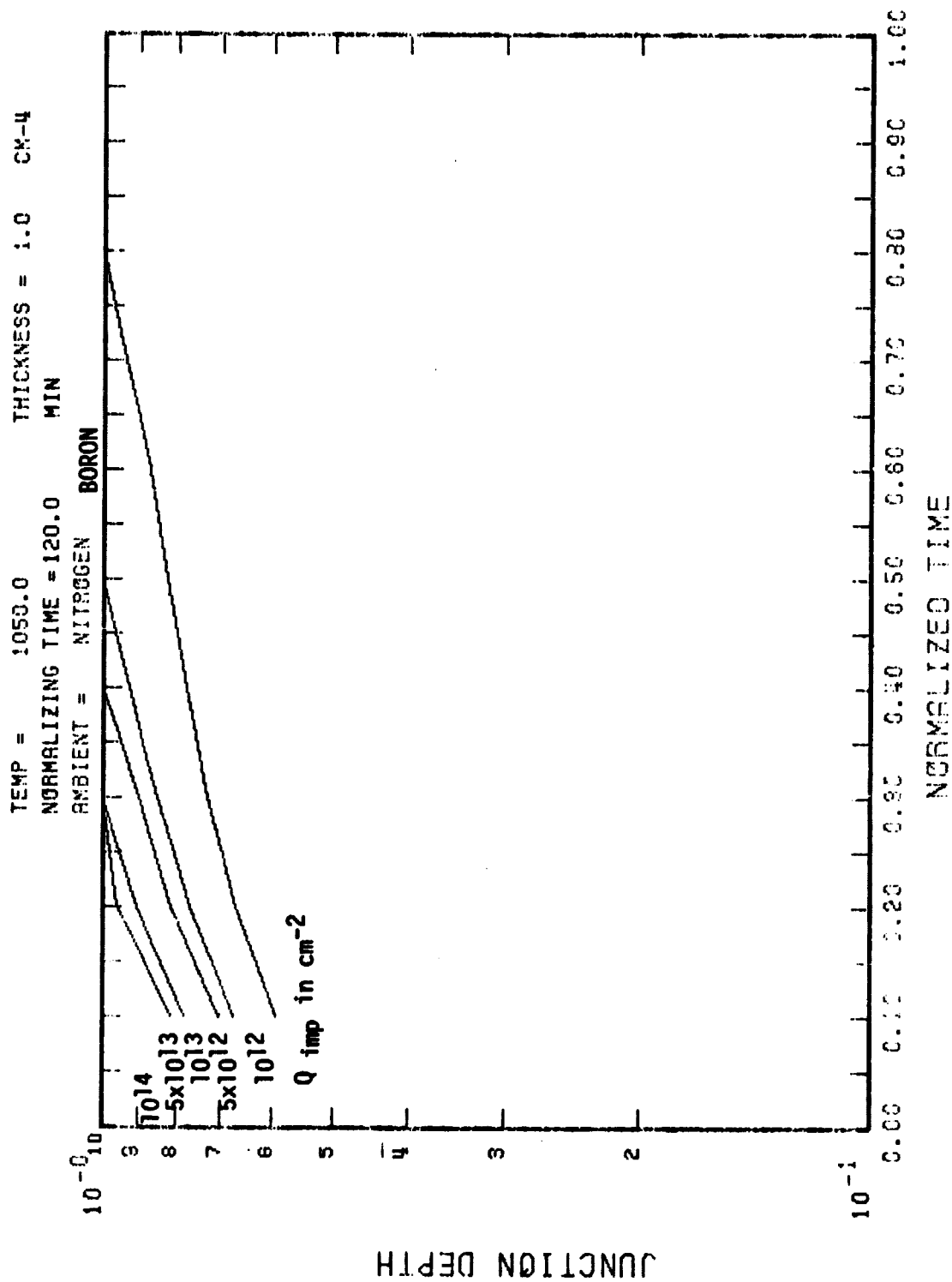


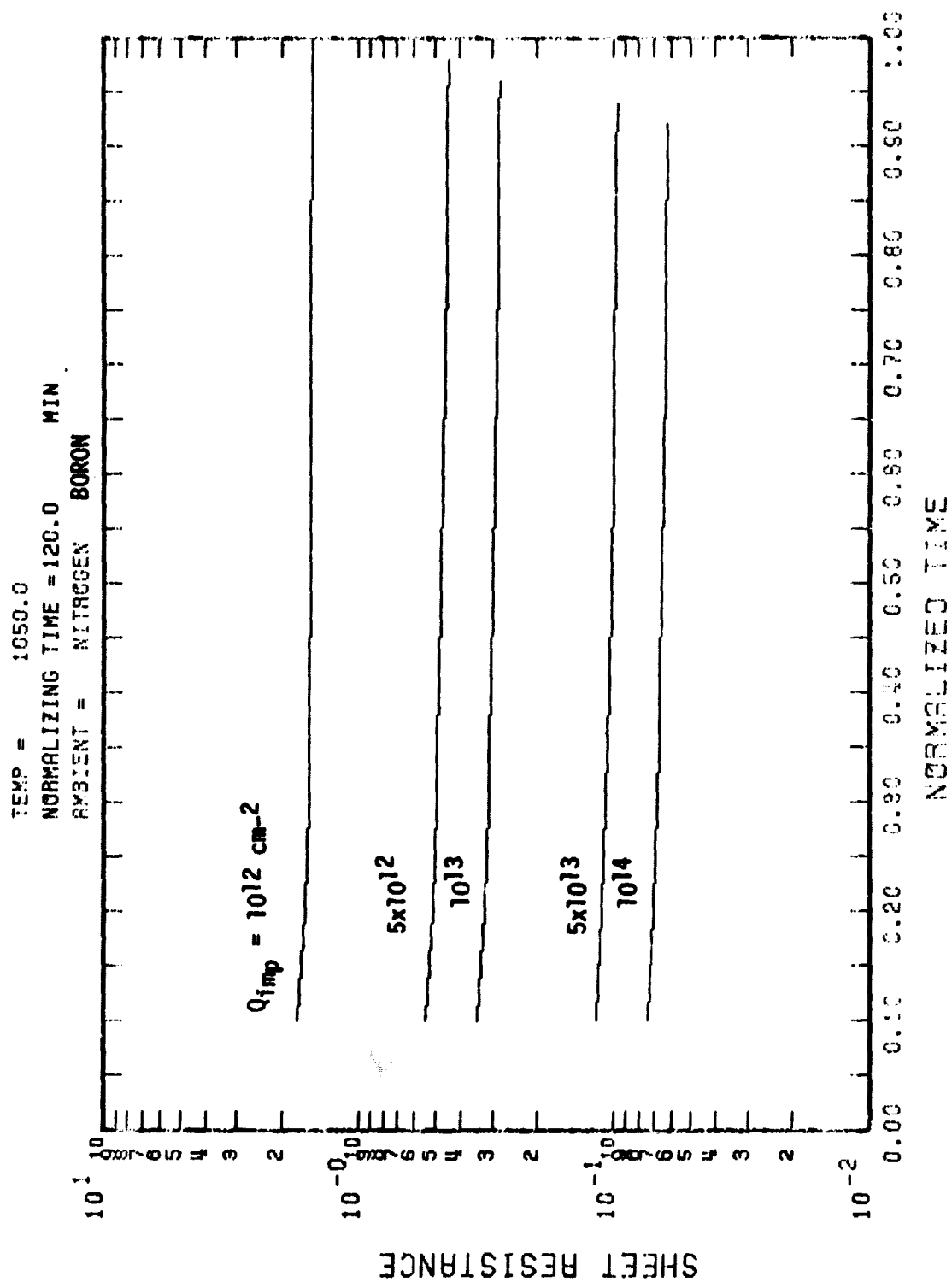


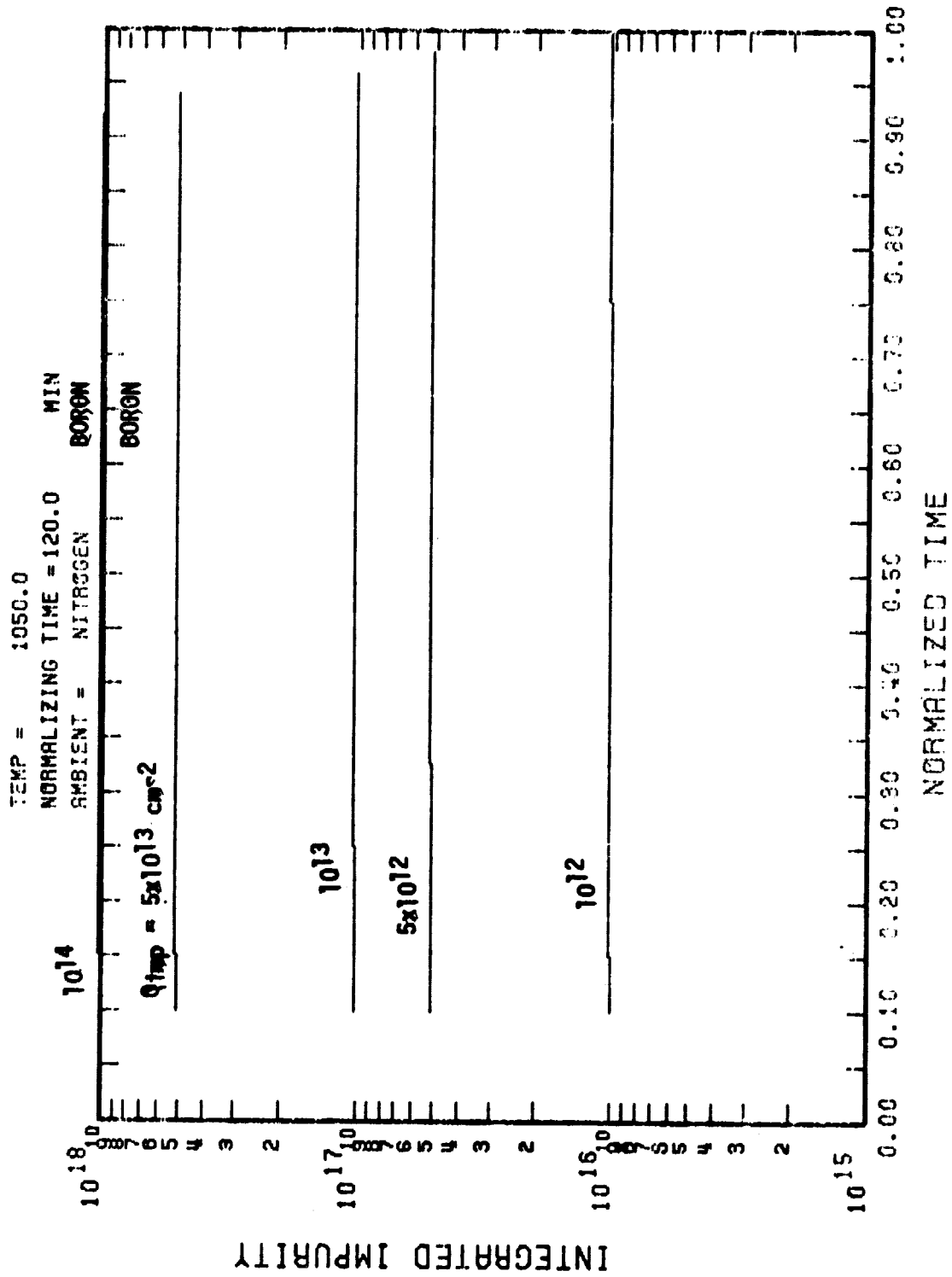






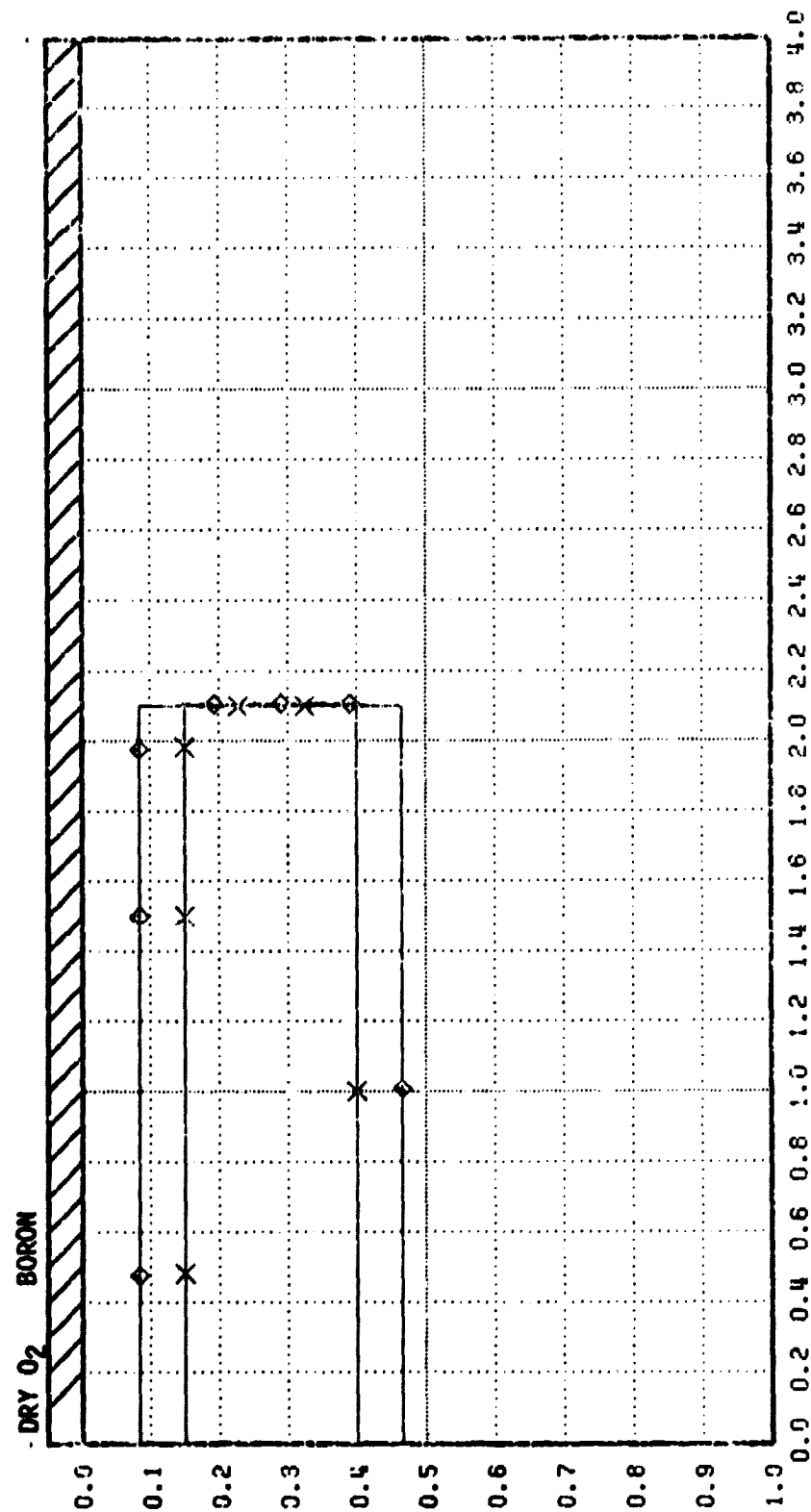






λ^2 TEMPERATURE = 0.0000
 TIME STEP = 1000.
 TIME = 0
 TIME = 0.00

E - 1.0E20
 O - 1.0E19
 A - 1.0E18
 + - 1.0E17
 X - 1.0E16
 D - 1.0E15



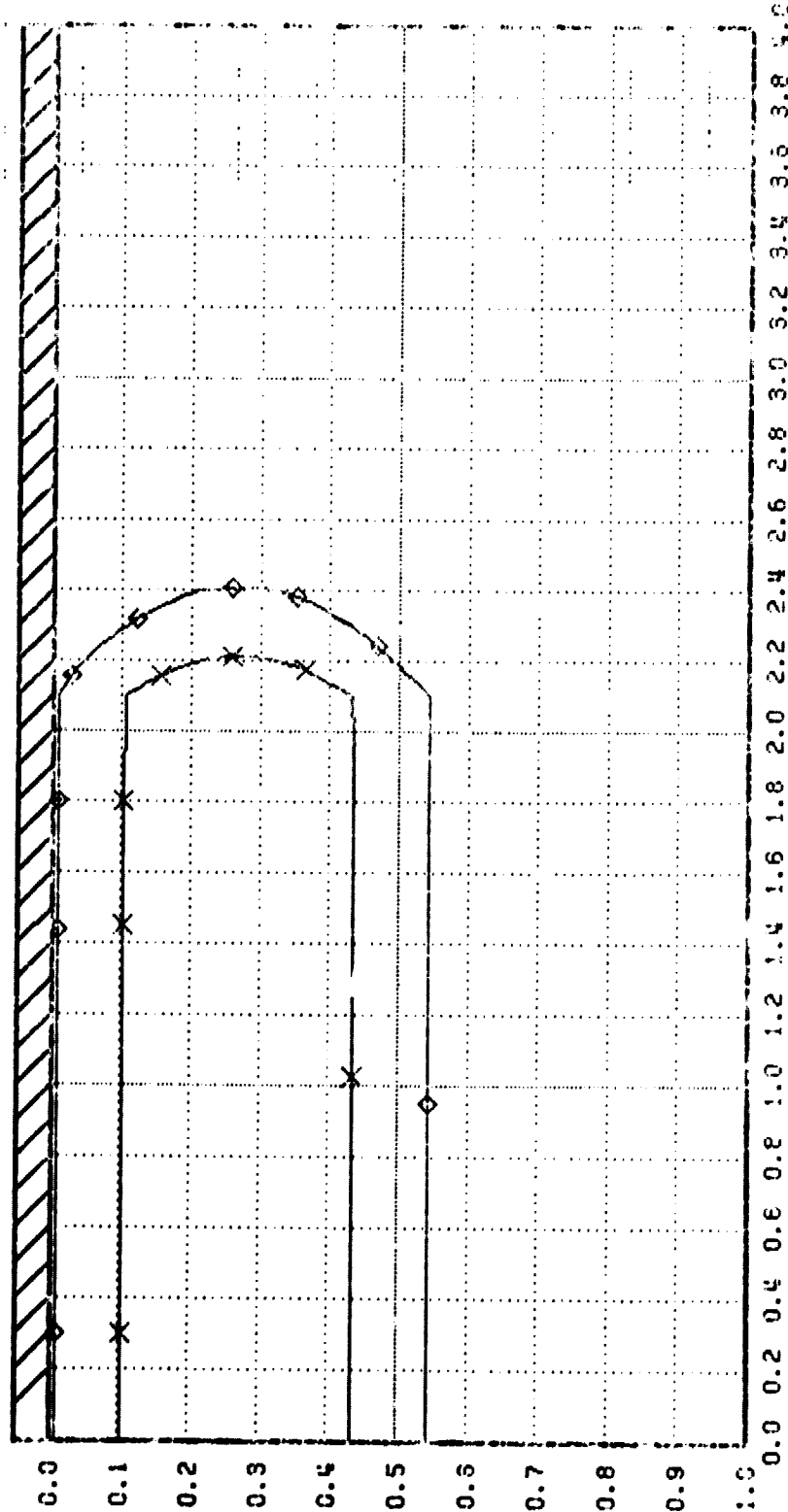
ORIGINAL PAGE IS
OF POOR QUALITY

A 20

χ^2
 TEMPERATURE
 TIME STEP
 TIME
 DRY O₂ BORON

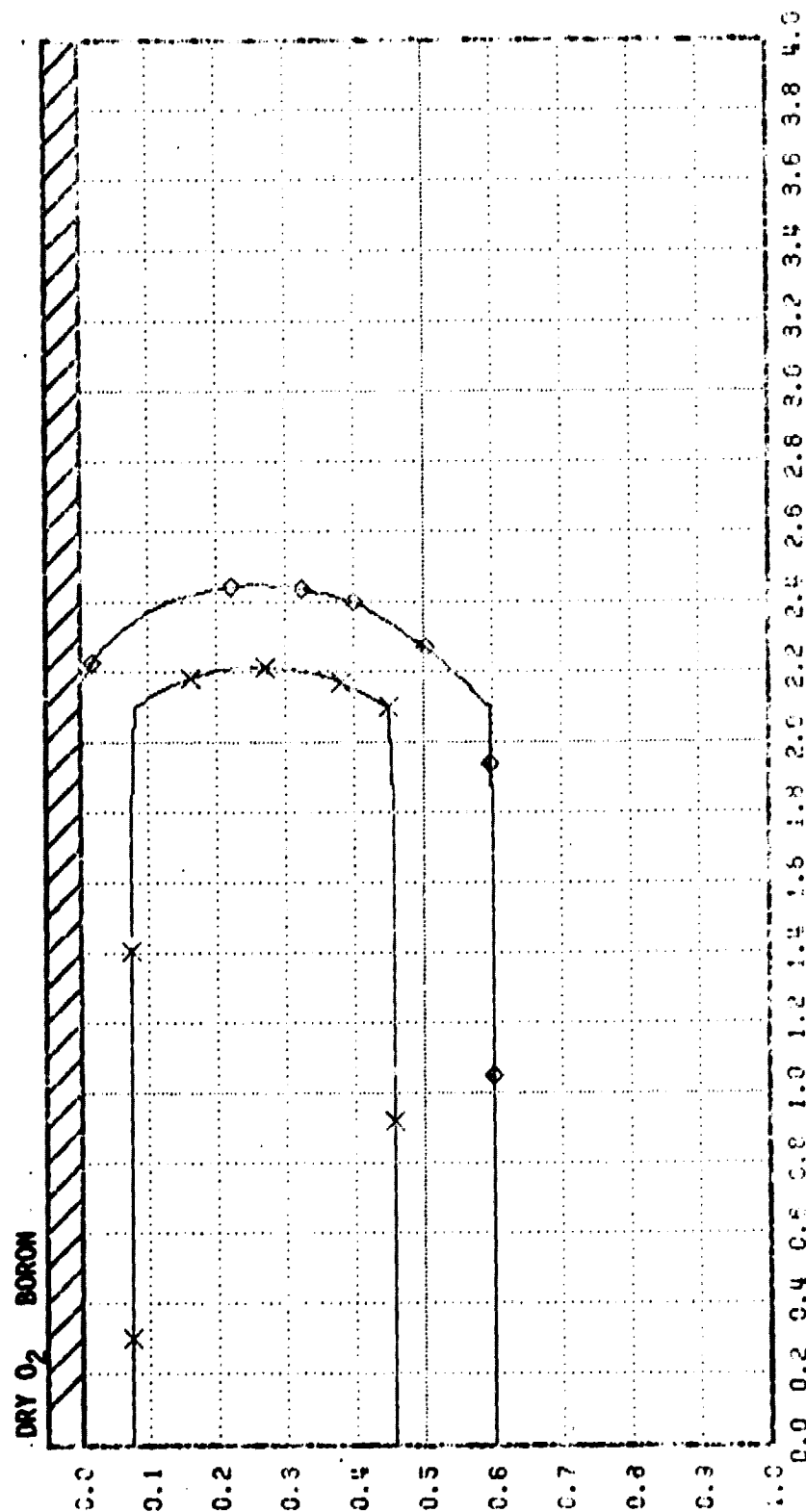
= 0.0000
 = 1000.
 = 20
 = 1440.00

- 1.0E20
 - 1.0E18
 - 1.0E16
 - 1.0E17
 - 1.0E18
 - 1.0E15

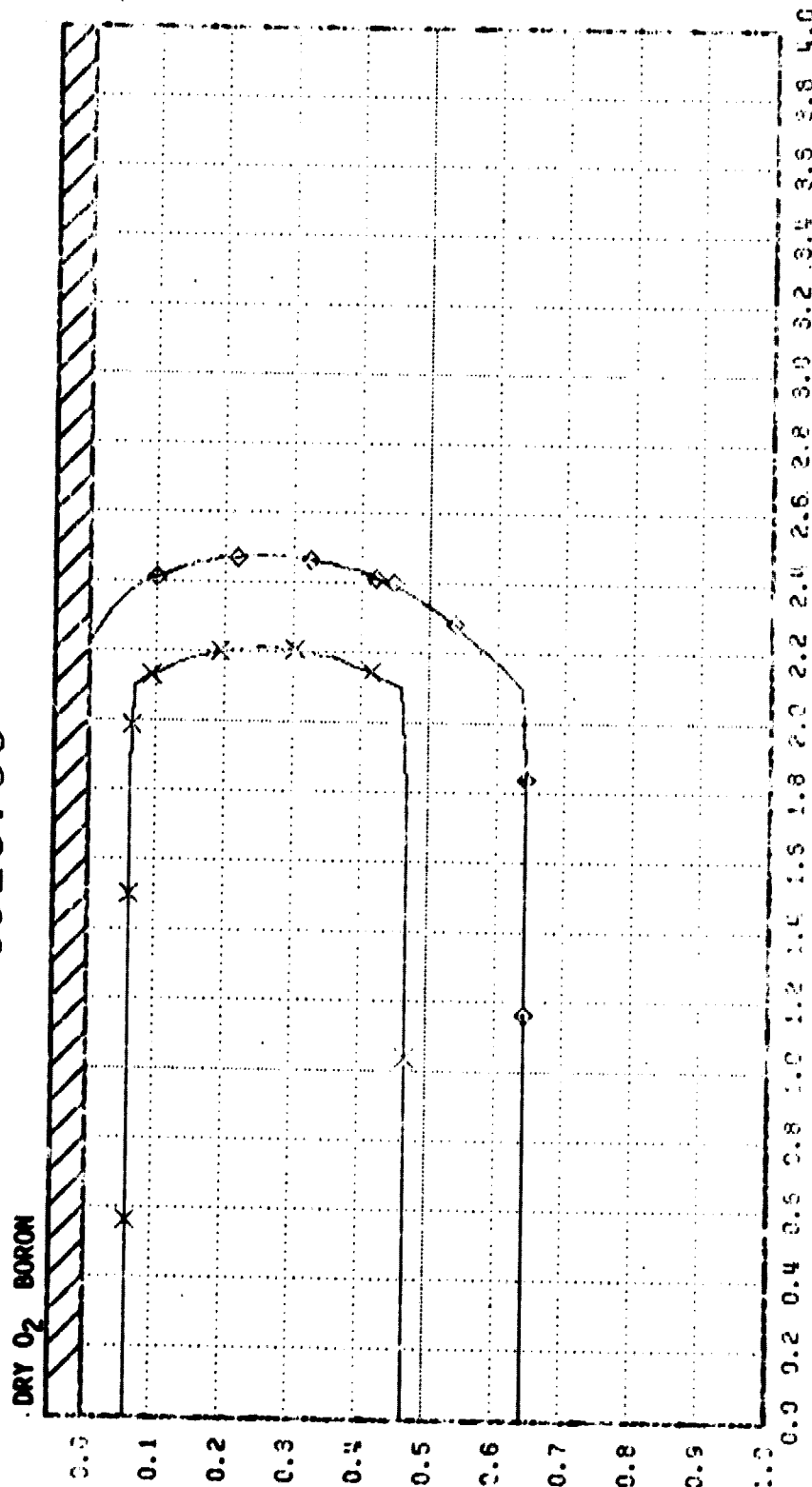


λ^2 TEMPERATURE = 0.0000
 TIME STEP = 1000.
 TIME = 40
 = 2880.00

E = 1.0520
 O = 1.0519
 A = 1.0518
 + = 1.0517
 X = 1.0516
 O = 1.0515

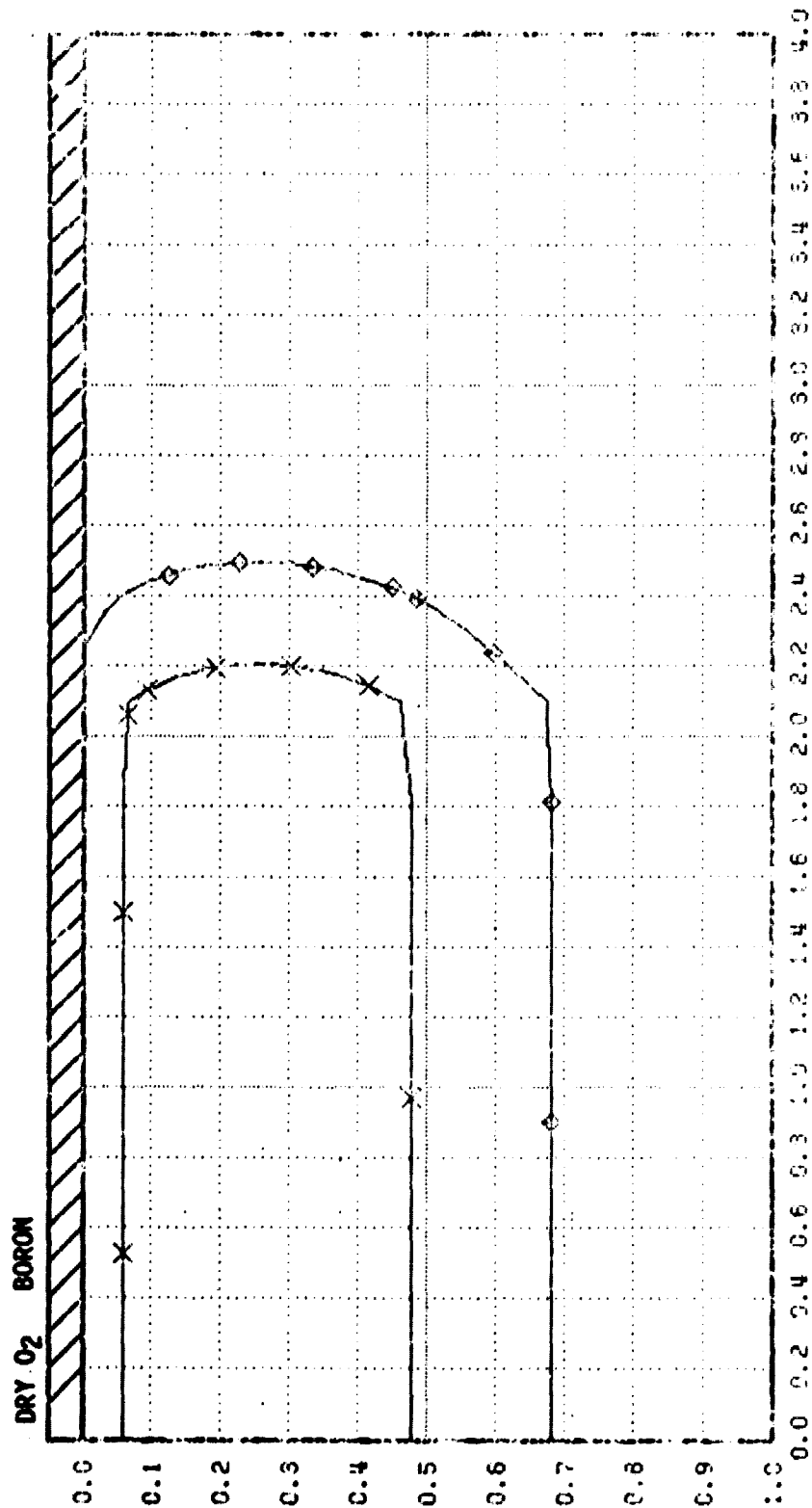


X^2 TEMPERATURE = 0.0000
 TIME STEP = 1000.
 TIME = 60
 DRY O₂ BORON = 4320.00



χ^2
 TEMPERATURE = 0.0000
 TIME STEP = 1000.
 TIME = 80
 TIME = 5760.00

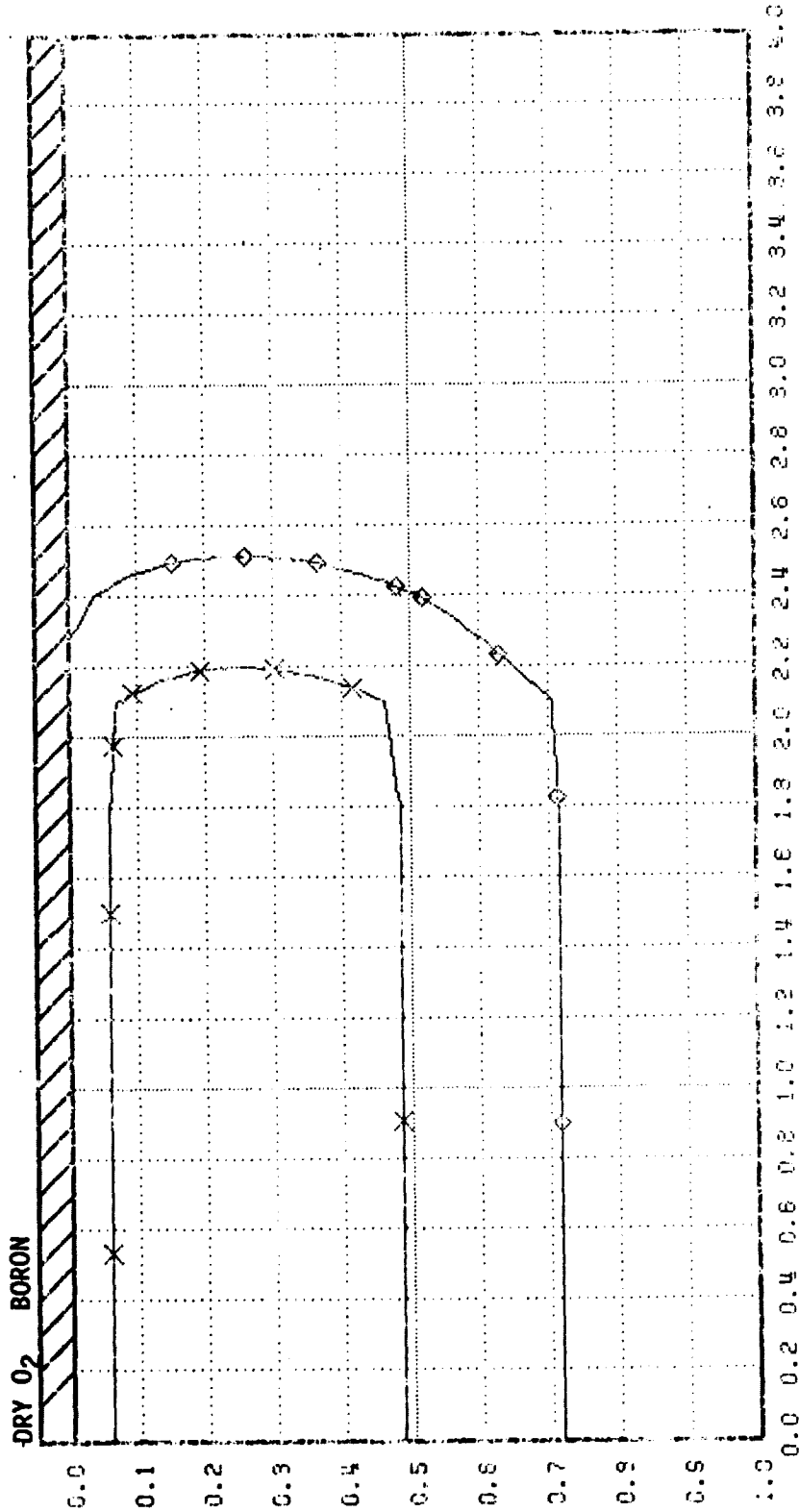
E 1.0220
 1.0219
 1.0218
 1.0217
 1.0216
 1.0215



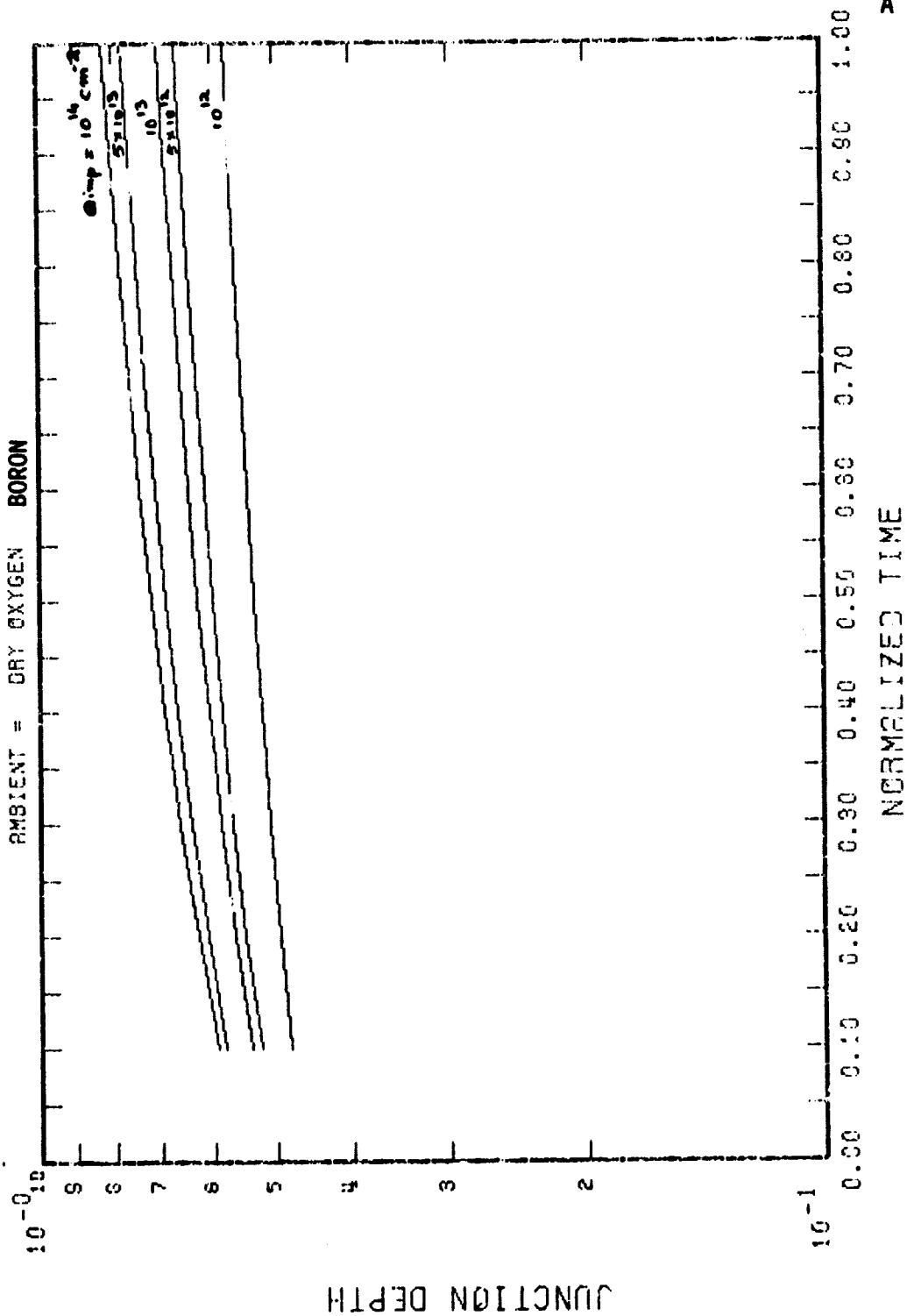
ORIGINAL PAGE IS
OF POOR QUALITY

A 24

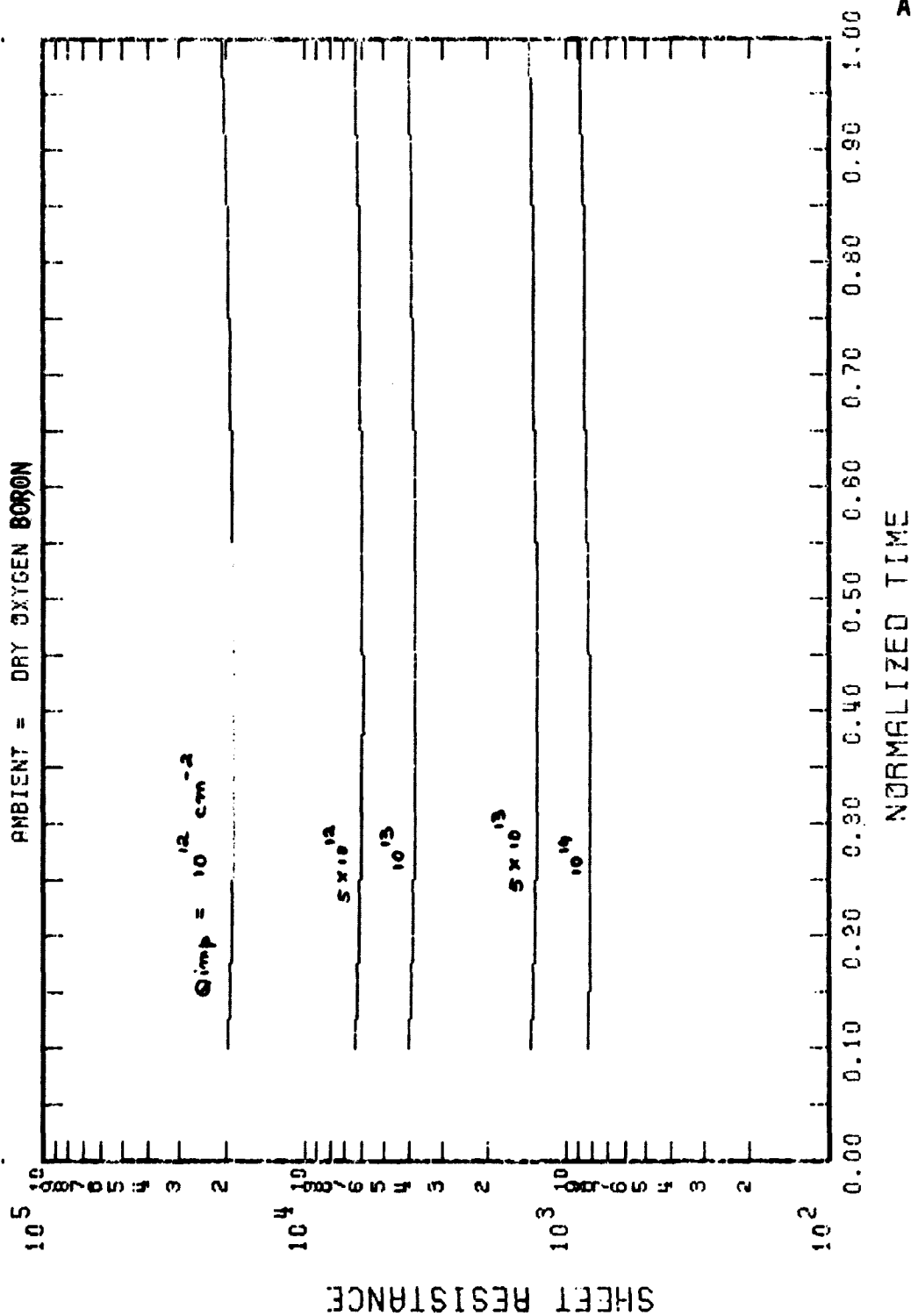
χ^2
 TEMPERATURE = 0.0000
 TIME STEP = 100.
 TIME = 100
 = 7200.00



TEMP = 900.0 THICKNESS = 0.0 CM-H
 NORMALIZING TIME = 1400.0 MIN
 AMBIENT = DRY OXYGEN BORON

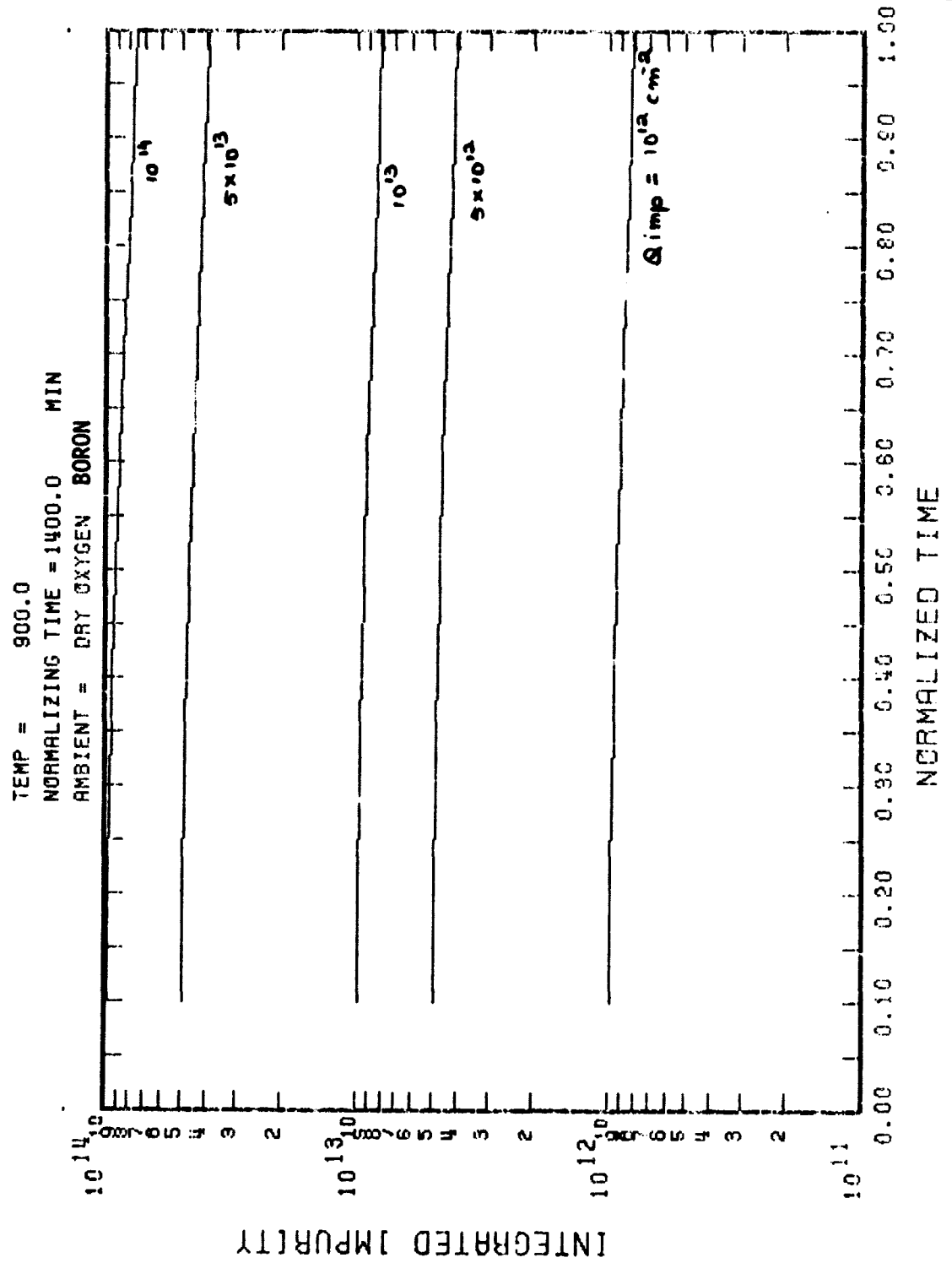


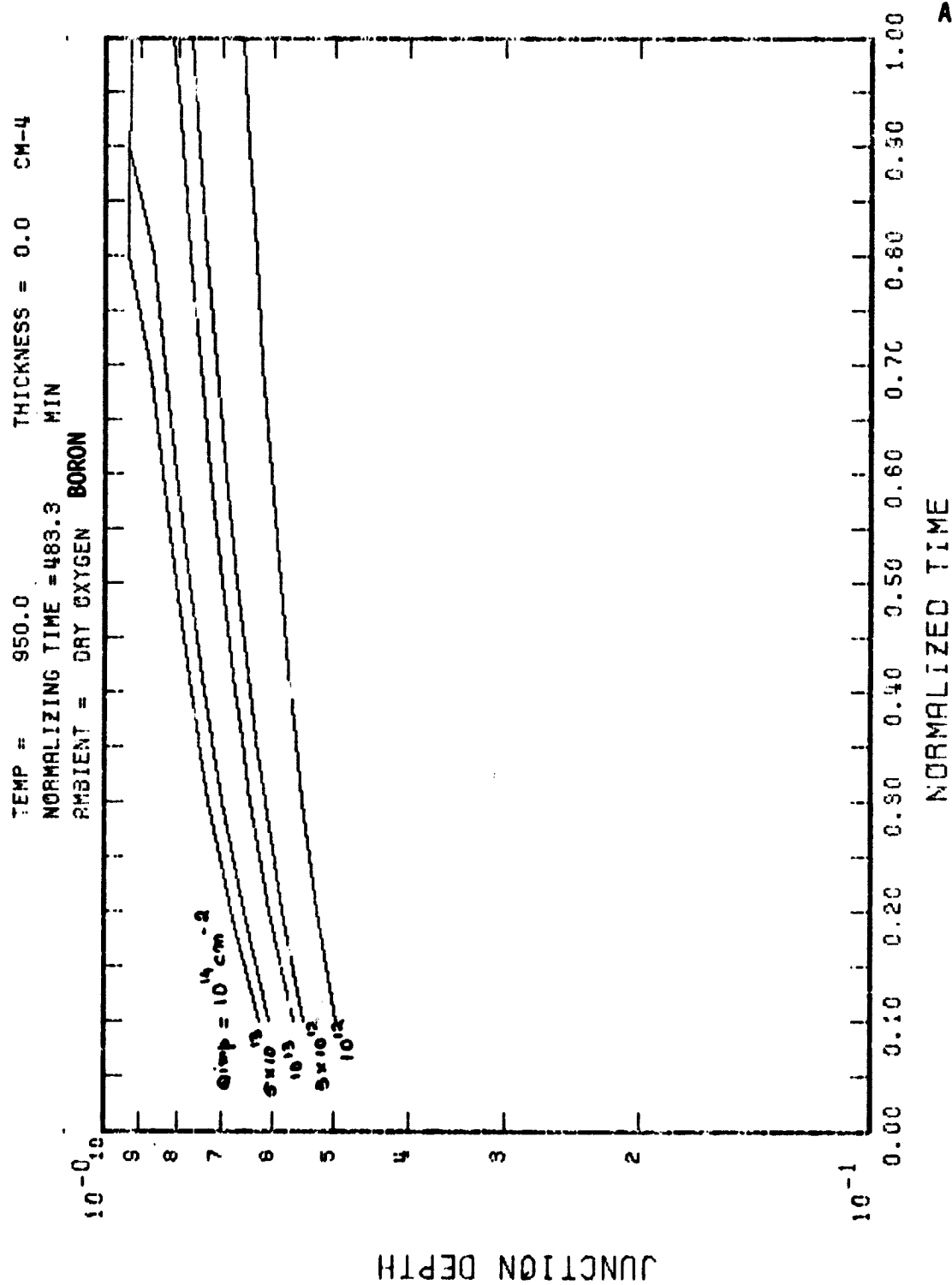
TEMP = 900.0
 NORMALIZING TIME = 1400.0 MIN
 AMBIENT = DRY OXYGEN BORON



ORIGINAL PAGE IS
OF POOR QUALITY

A 27

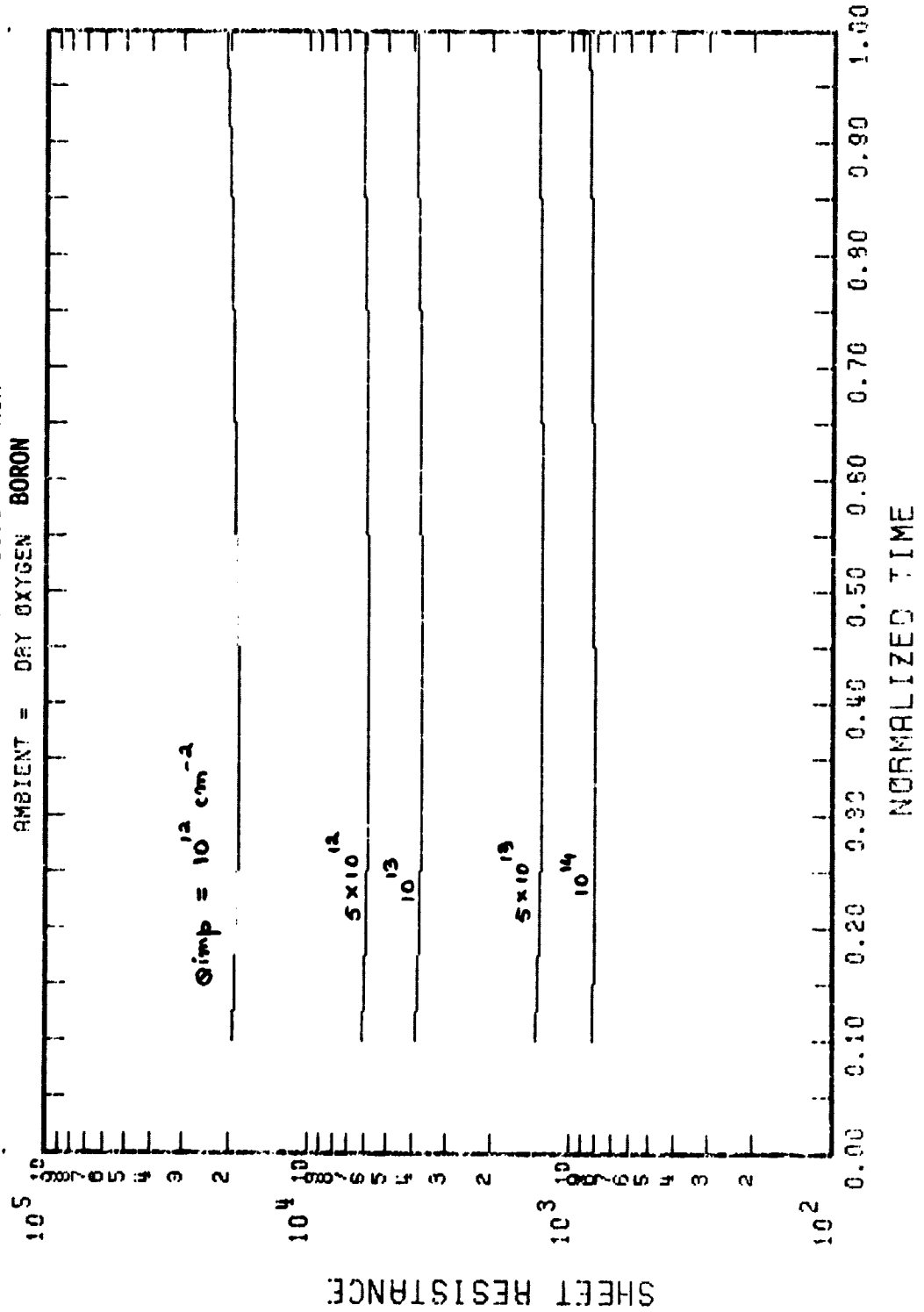




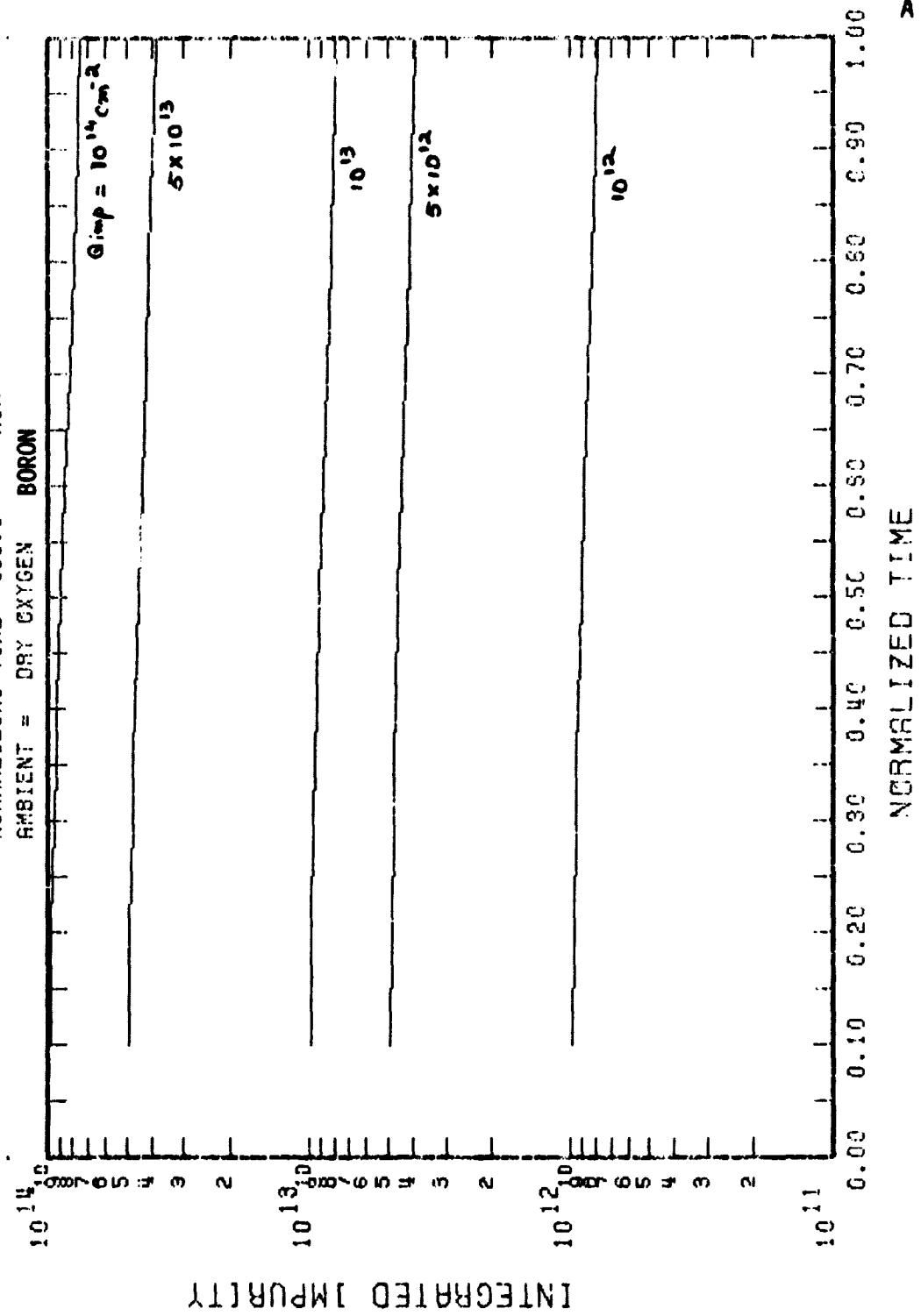
ORIGINAL PAGE
OF POOR QUALITY

A 29

TEMP = 950.0
NORMALIZING TIME = 483.3 MIN
AMBIENT = DRY OXYGEN BORON

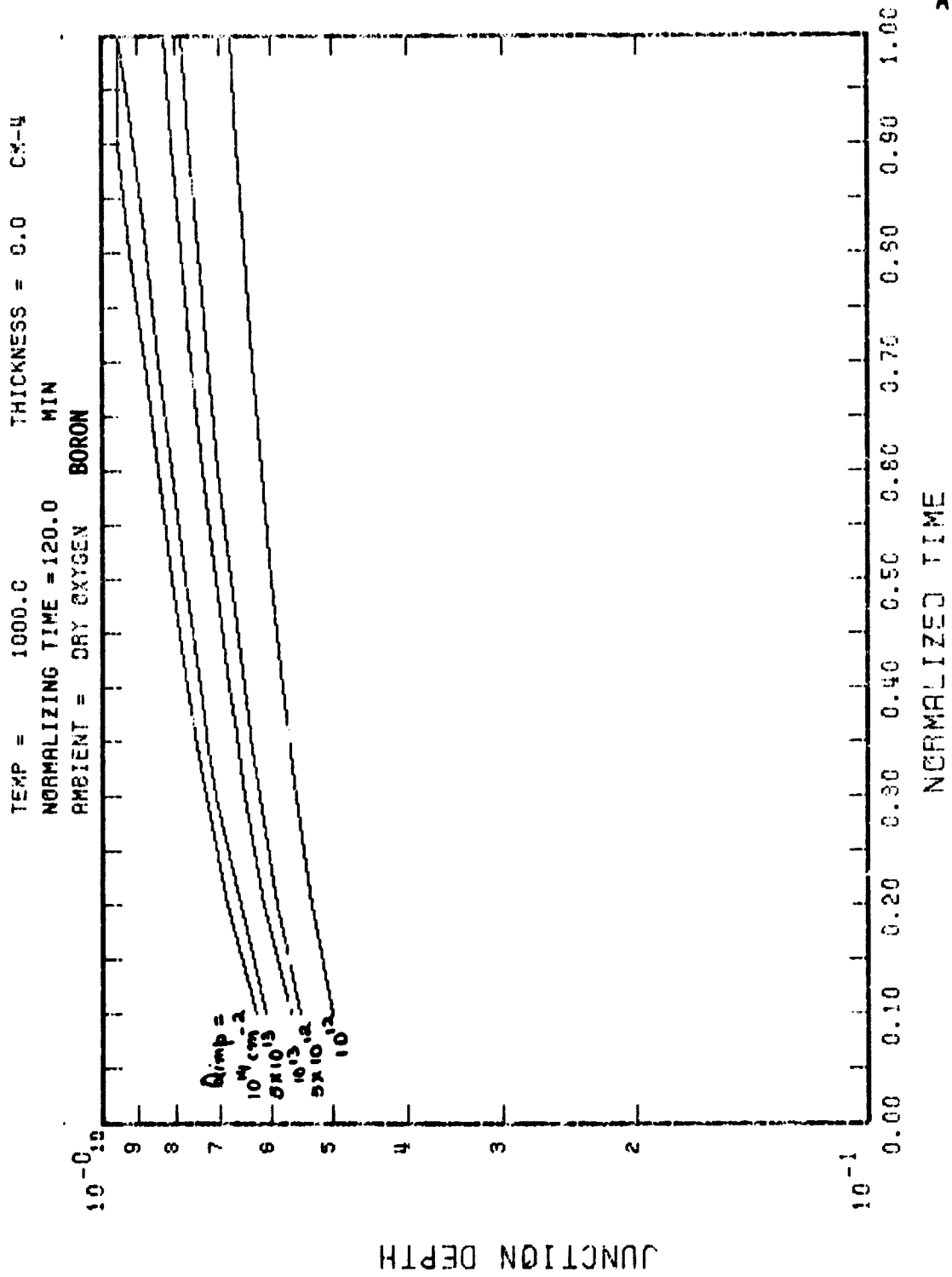


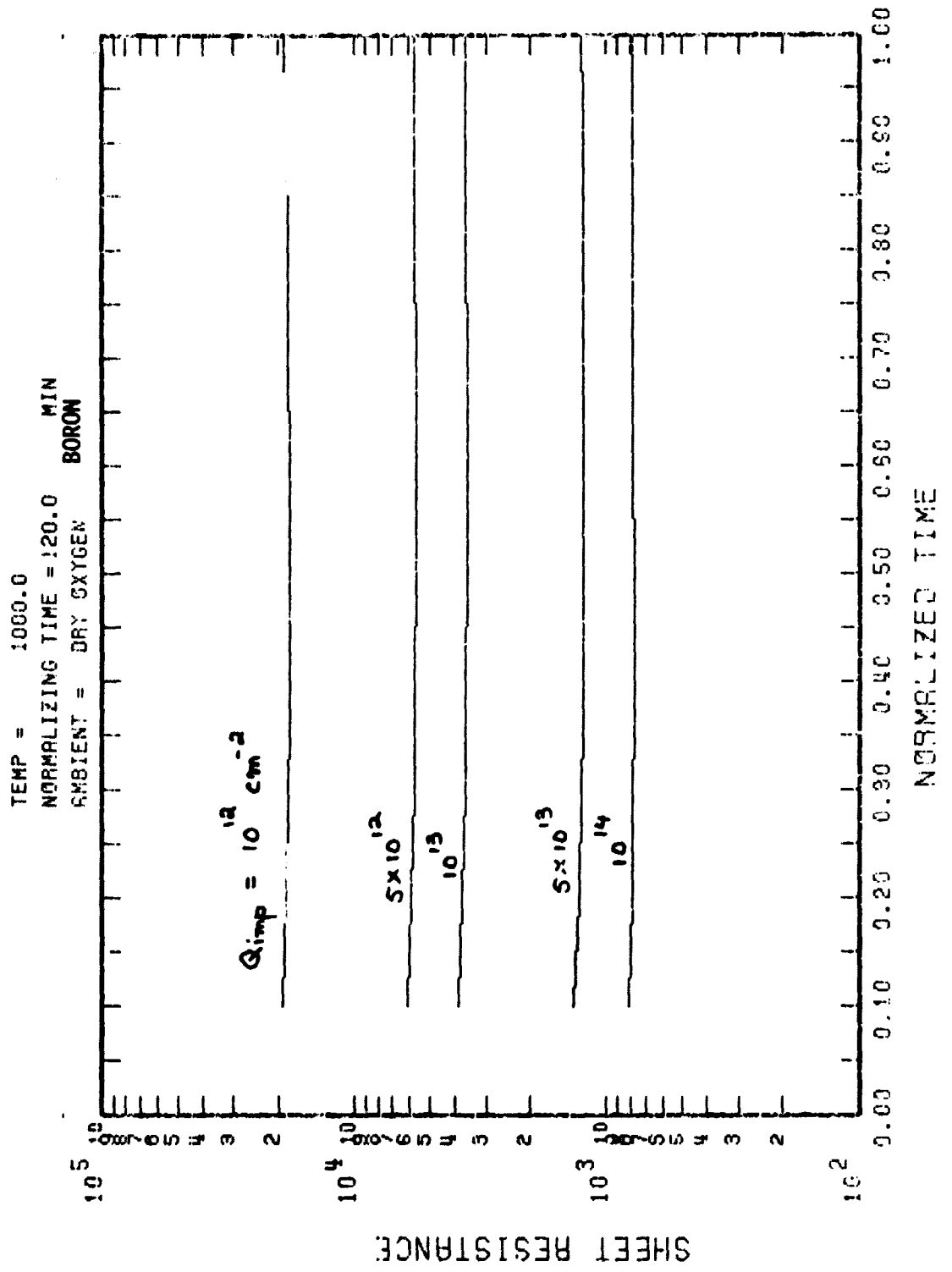
TEMP = 950.0
 NORMALIZING TIME = 483.3 MIN
 AMBIENT = DRY OXYGEN BORON

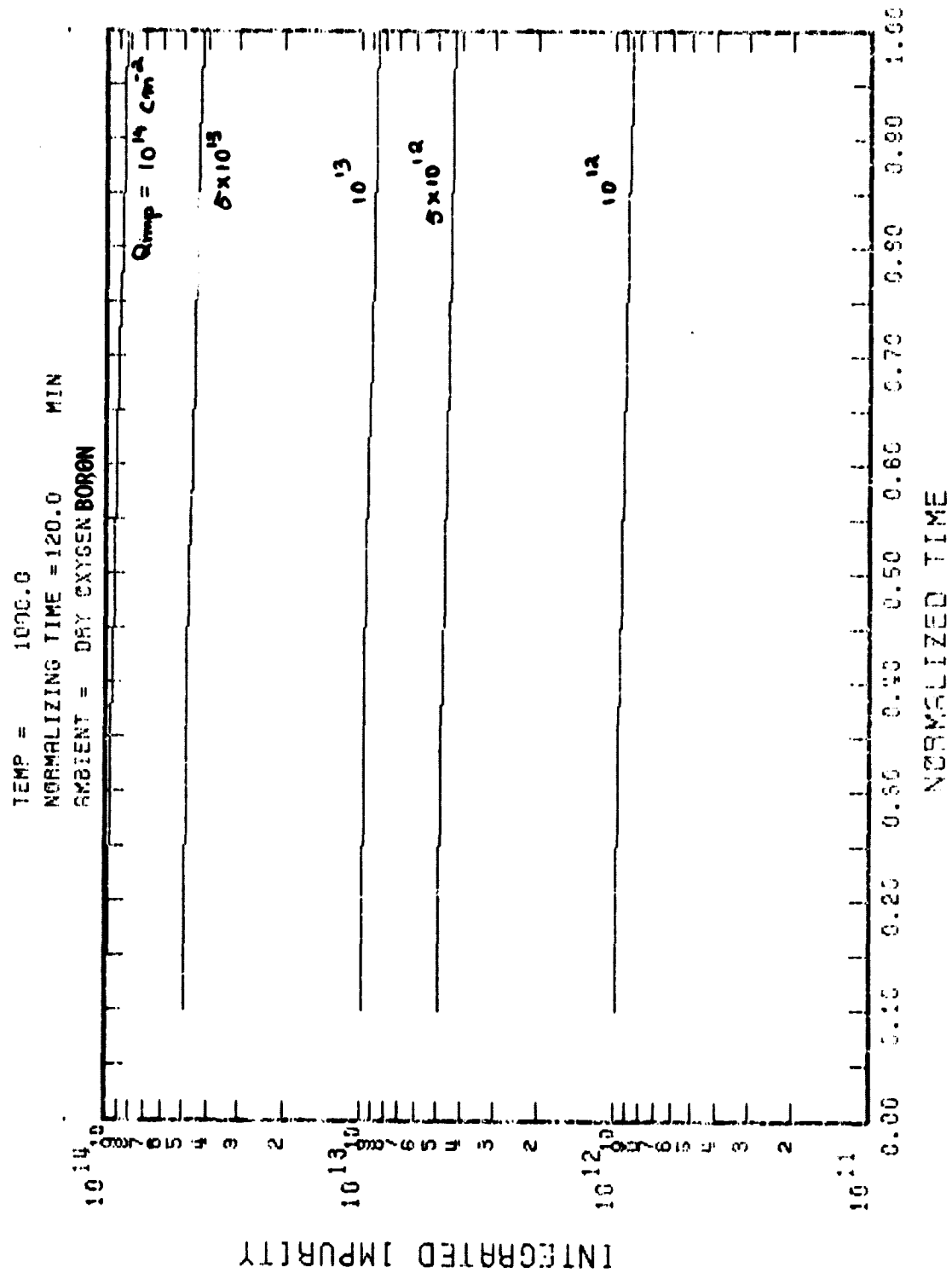


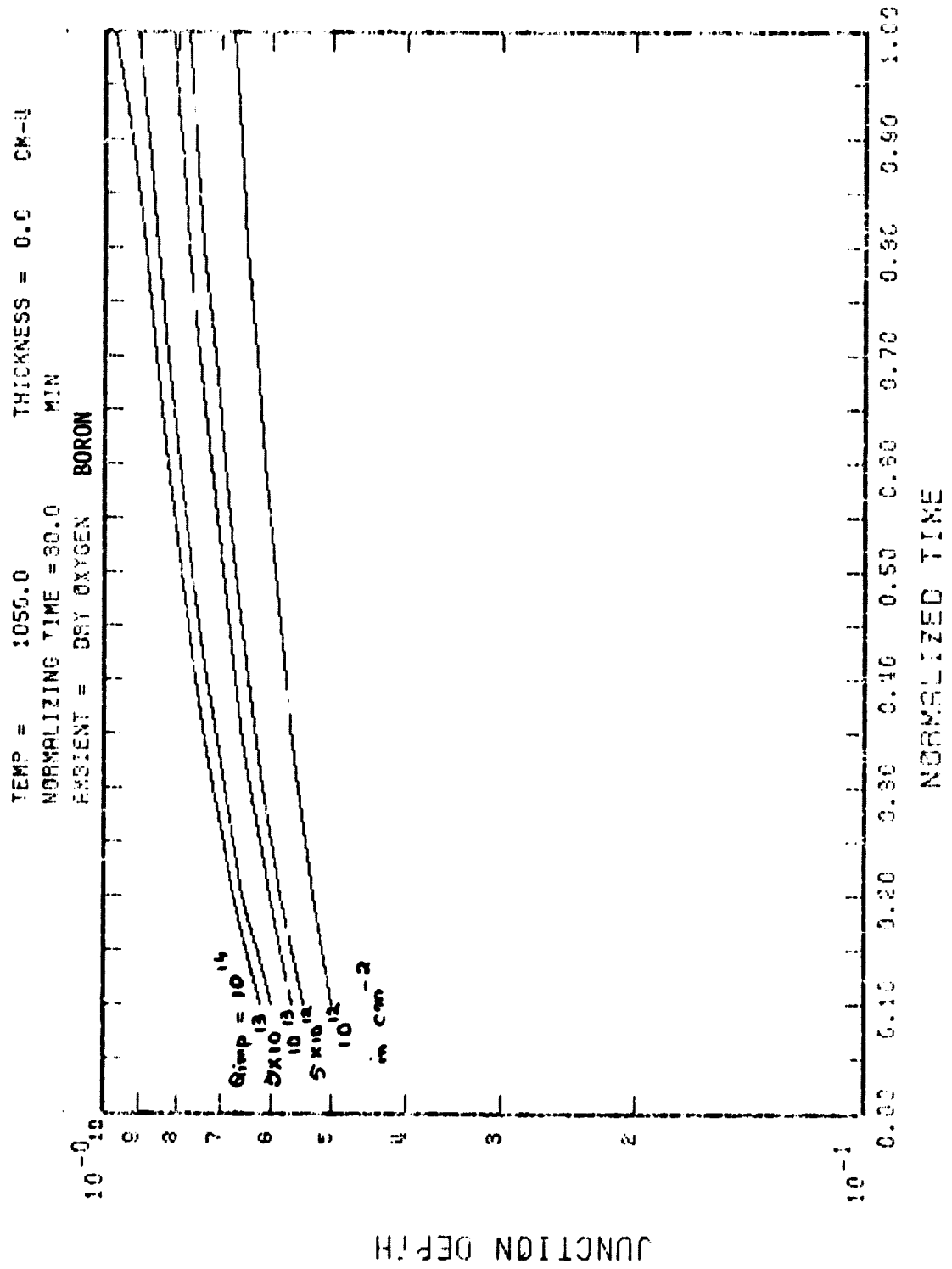
ORIGINAL PAGE IS
OF POOR QUALITY

A 31



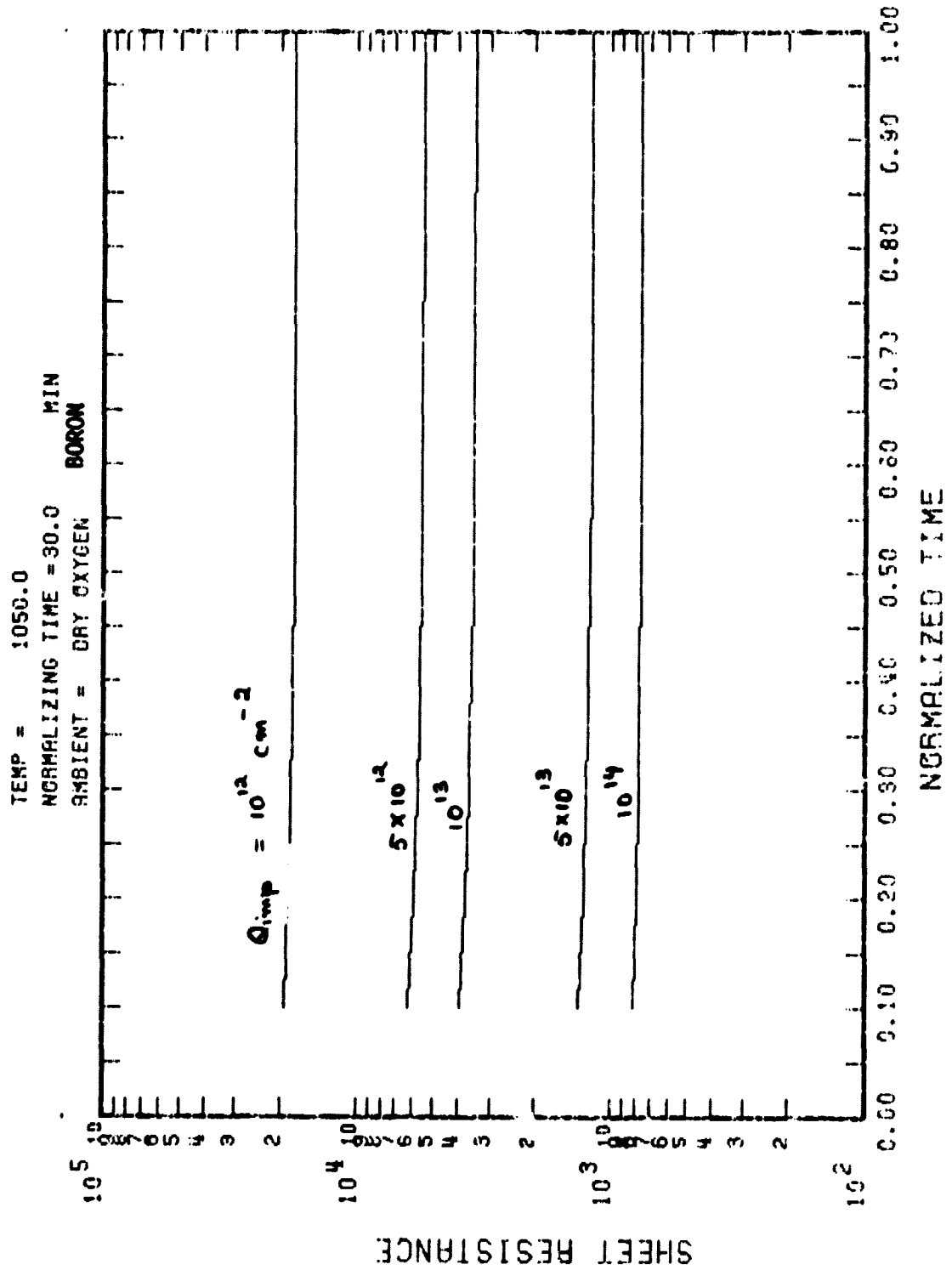




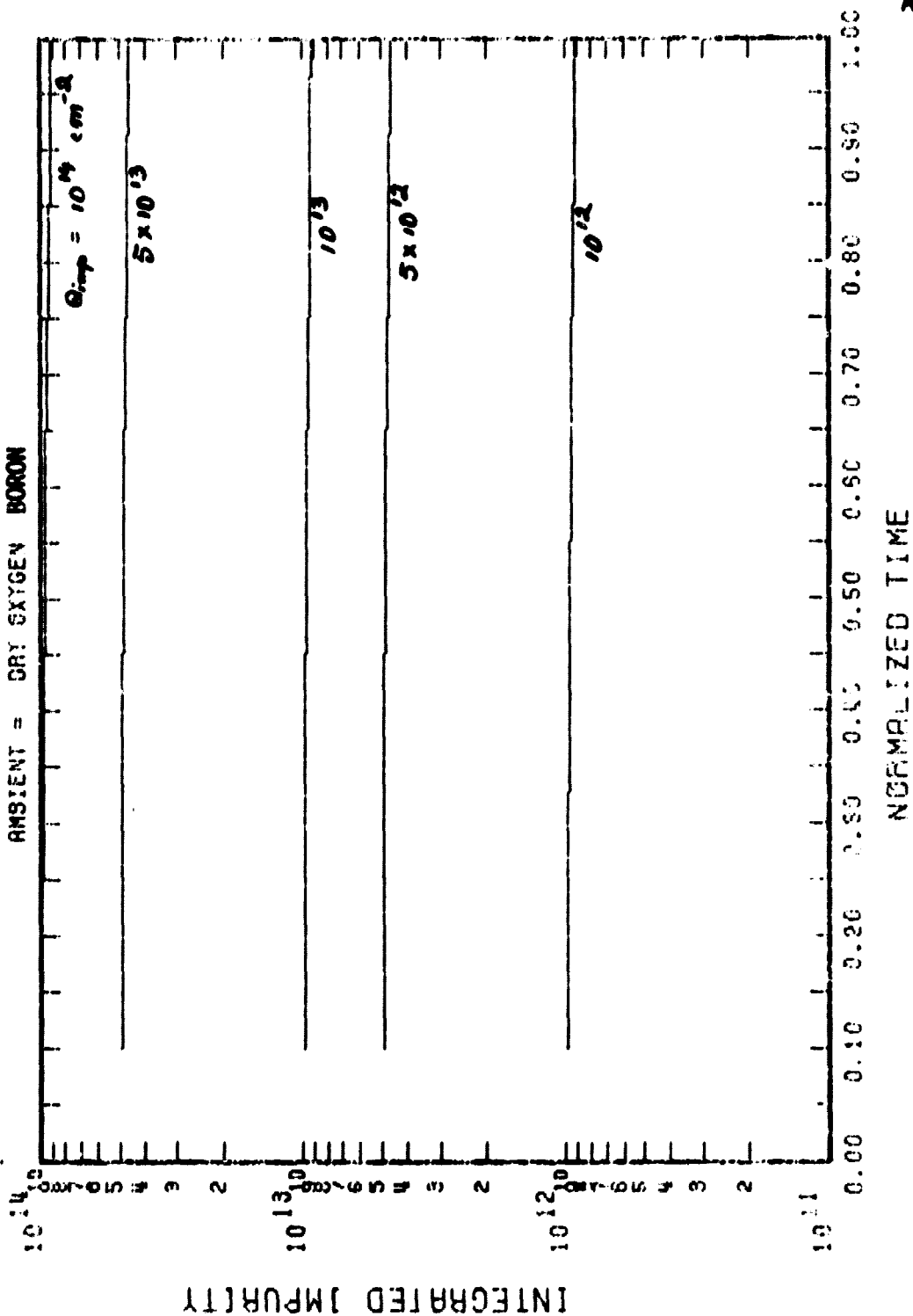


ORIGINAL PAGE IS
OF POOR QUALITY

A 35

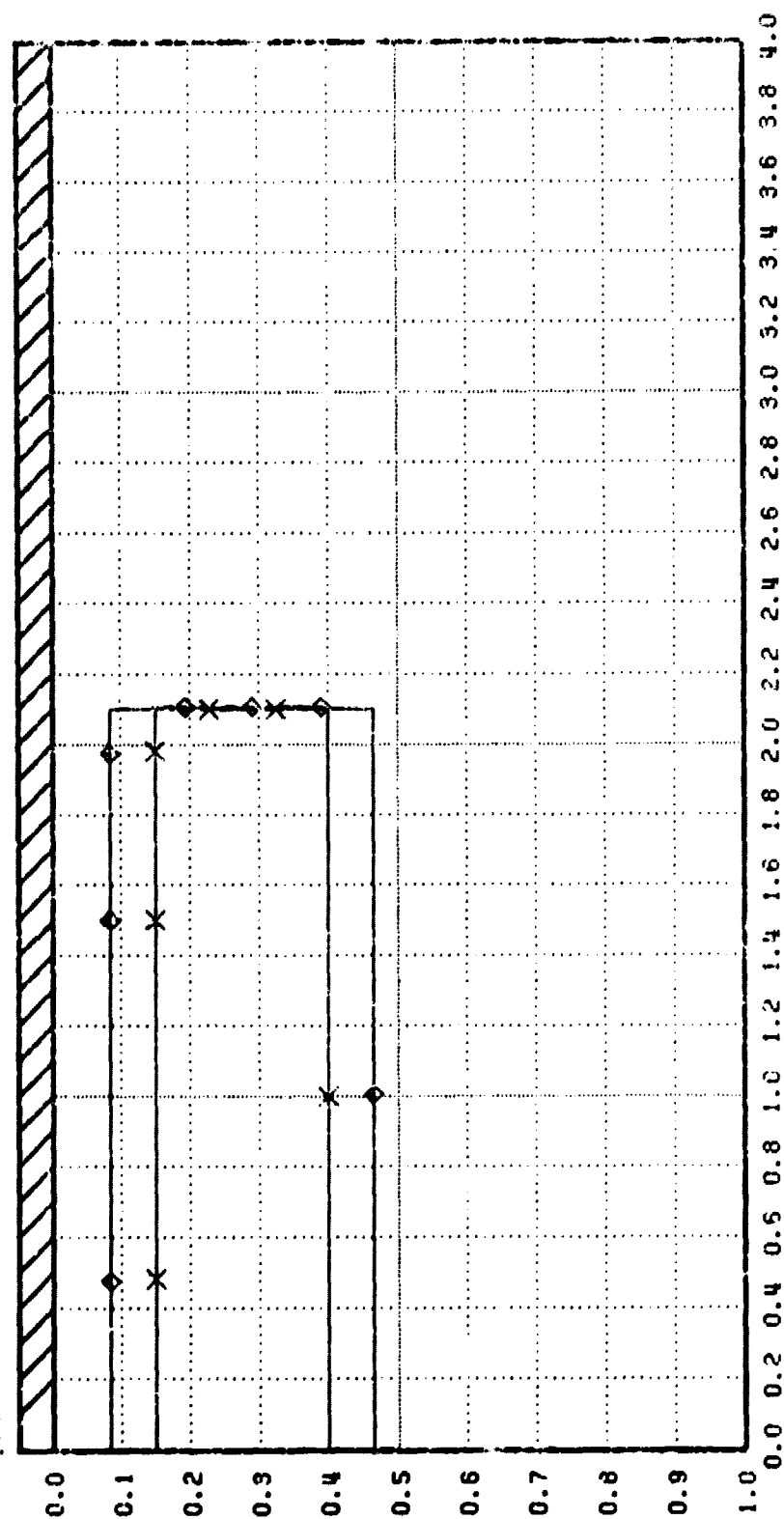


TEMP = 1050.0
 NORMALIZING TIME = 30.0 MIN
 AMBIENT = DRY OXYGEN BORON



32

λ^2
 TEMPERATURE = 0.0000
 TIME STEP = 1000.
 TIME = 0
 = 0.00
 BURN STEAM
 1.0E20
 1.0E19
 1.0E18
 1.0E17
 1.0E16
 1.0E15



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OF POOR QUALITY

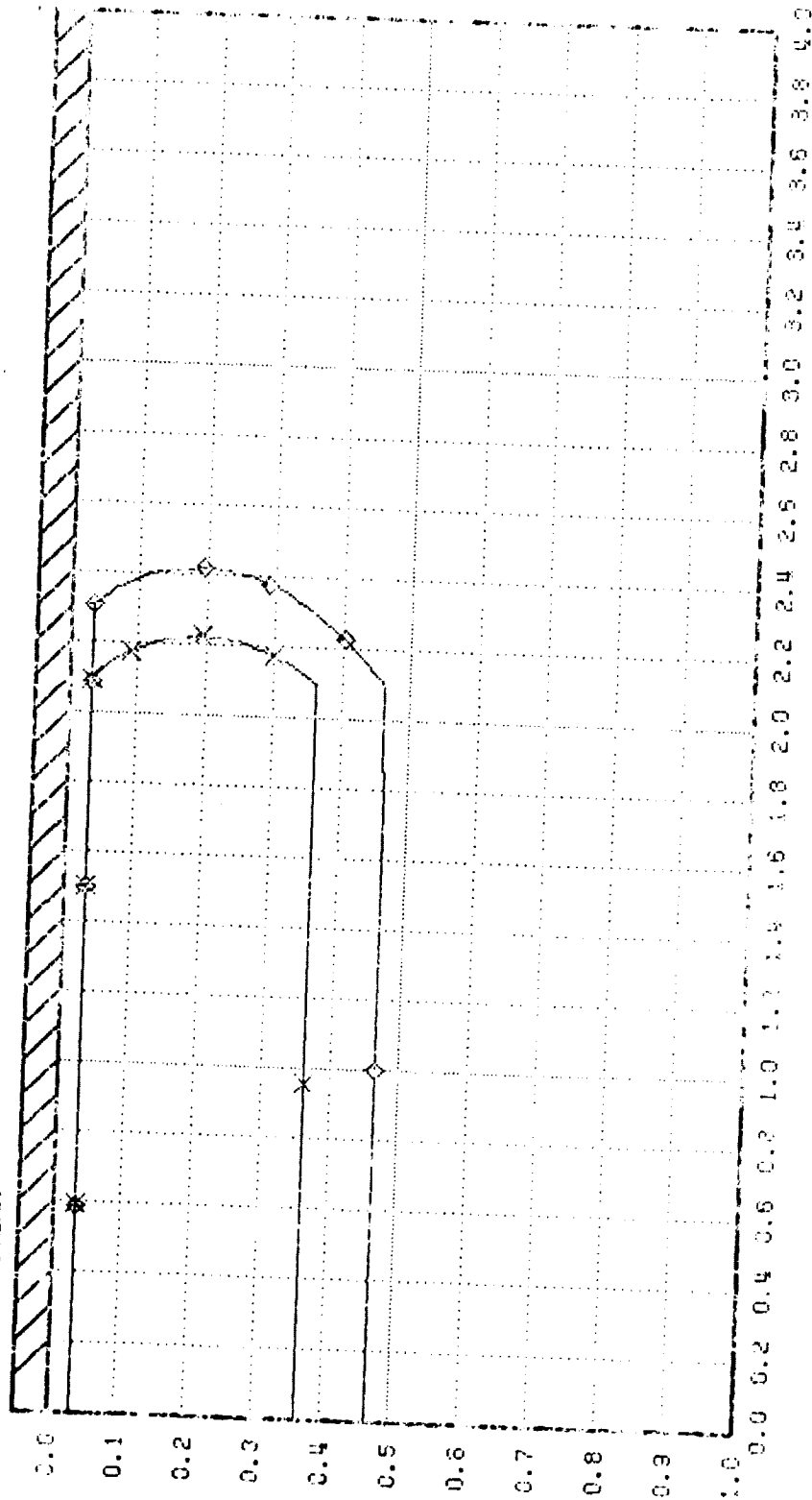
A 38

TEMPERATURE
TIME STEP
TIME
BORON STEAM

0.0000
1000.
20
1440.00

1.0520
1.0519
1.0518
1.0517
1.0516
1.0515

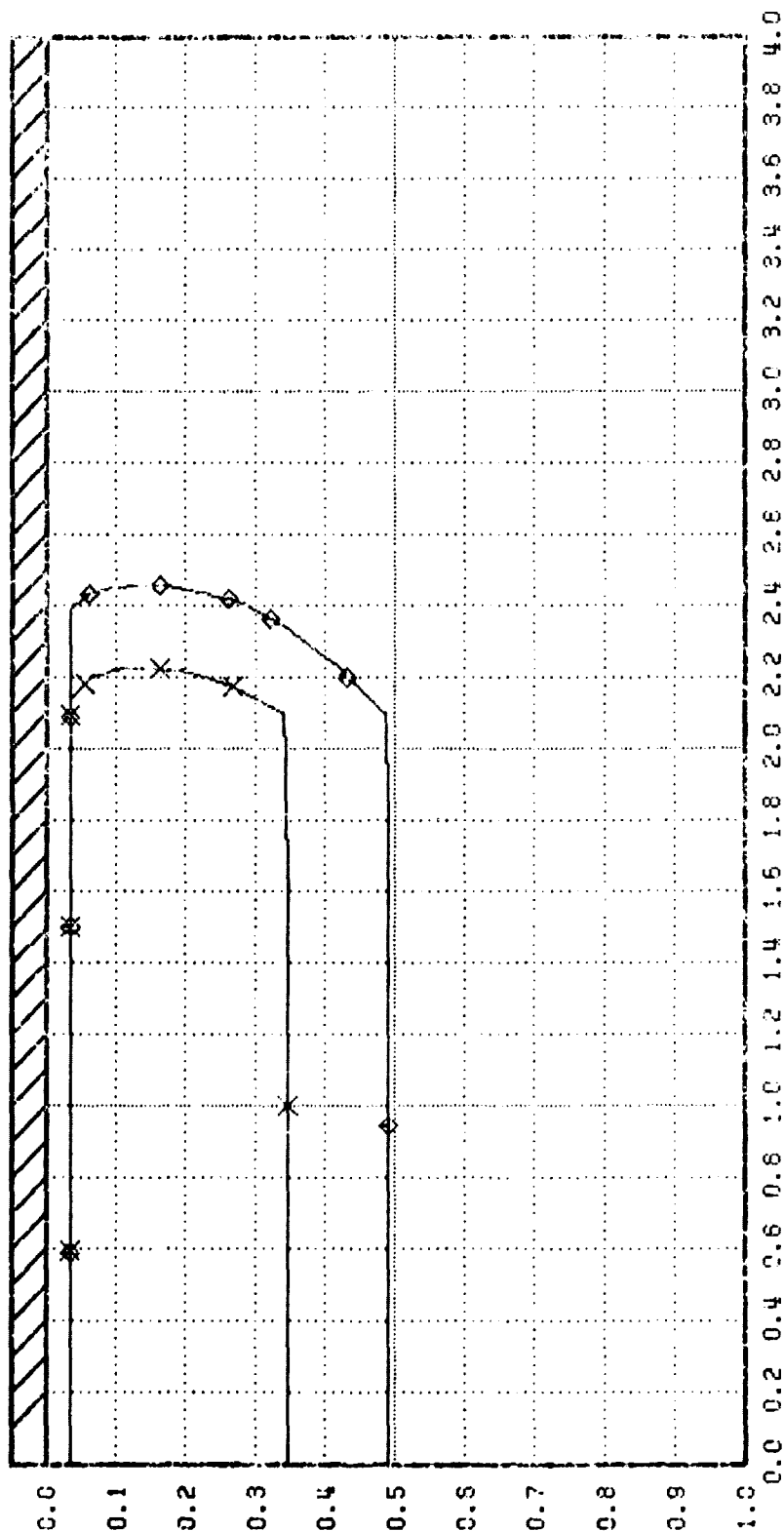
□ ○ △ + × ◇



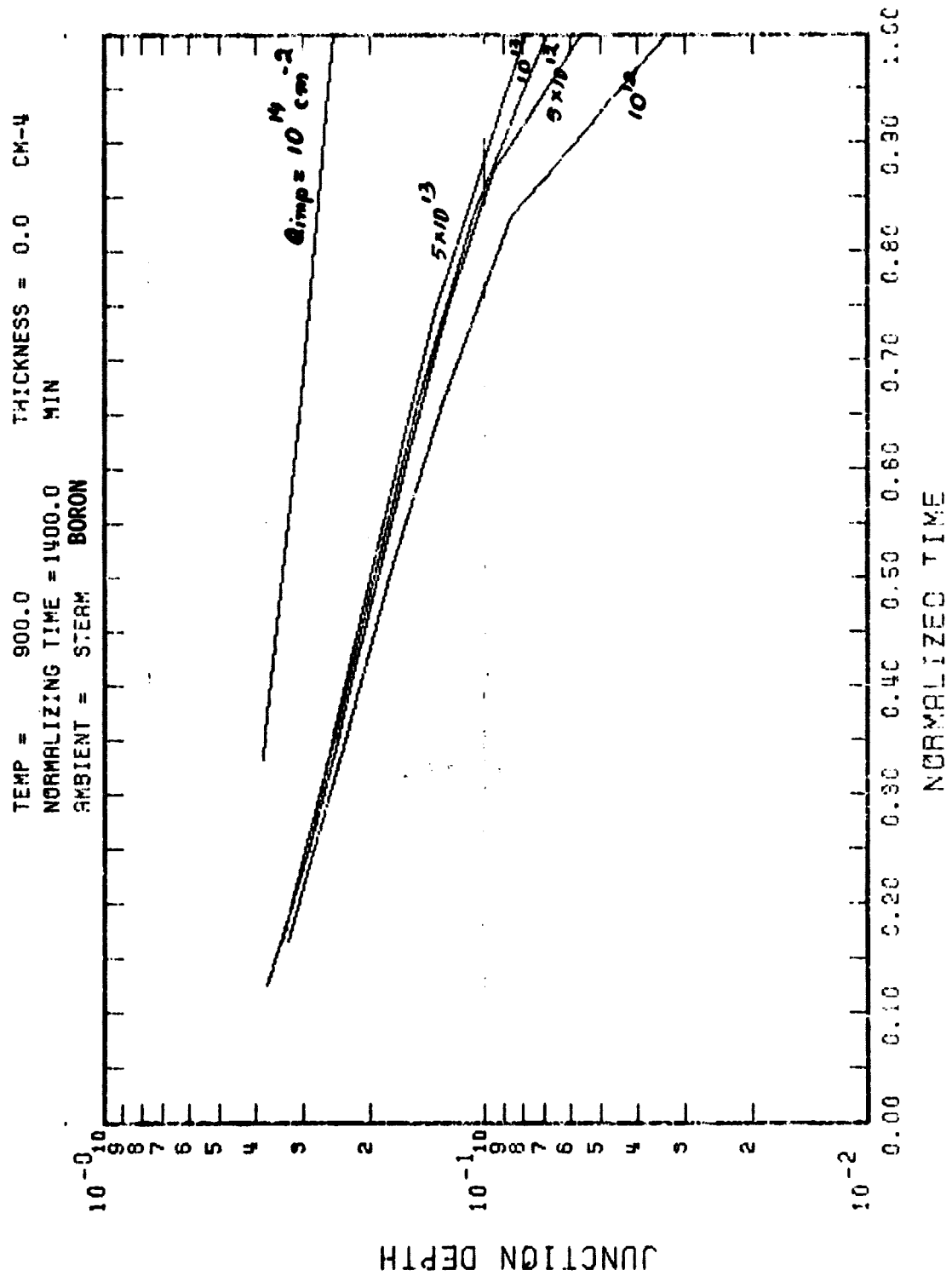
λ^2
 TEMPERATURE = 0.0000
 TIME STEP = 1000.
 TIME = 40
 TIME = 2880.00

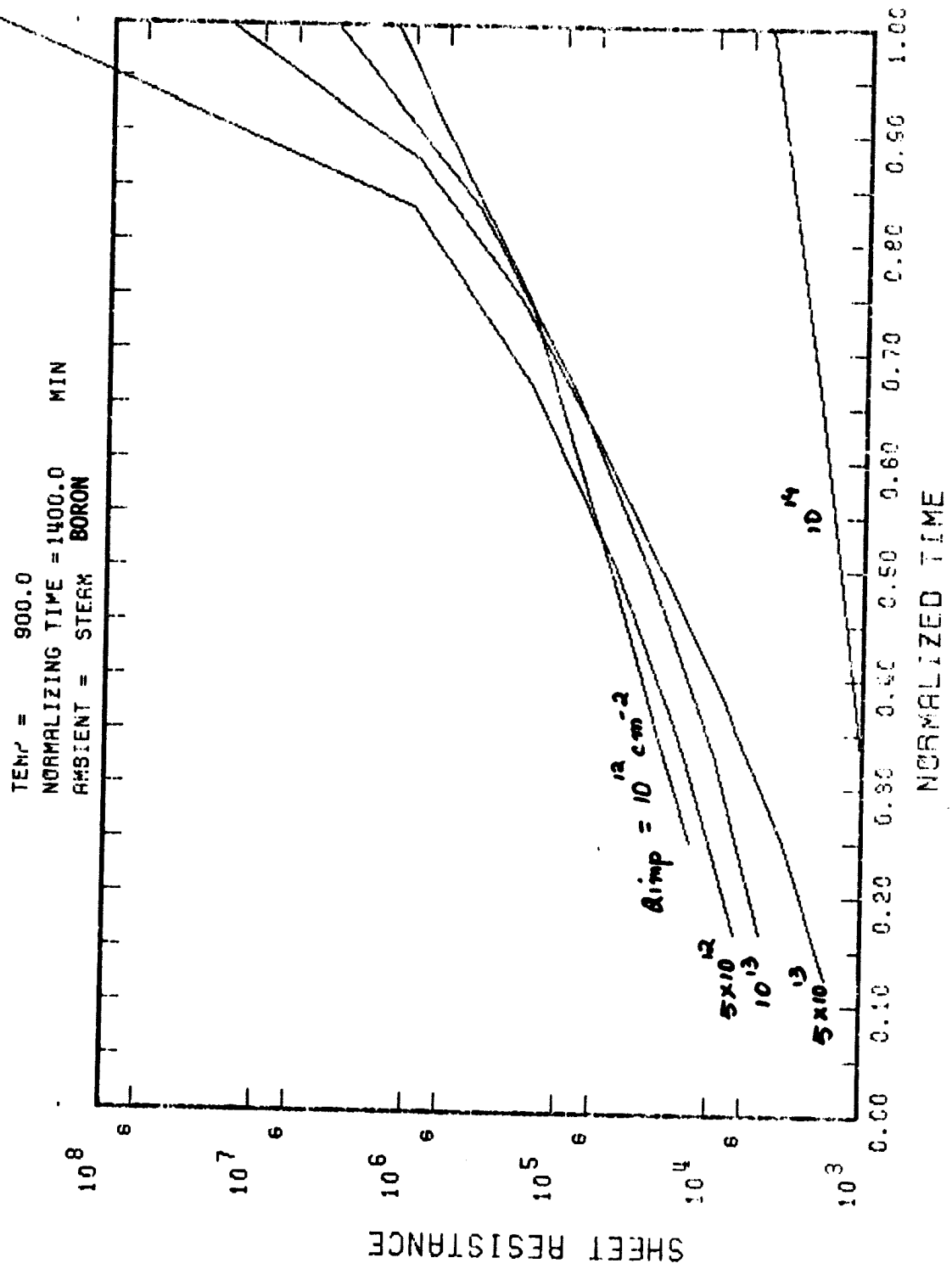
E - 1.0E20
 O - 1.0E19
 A - 1.0E18
 + - 1.0E17
 X - 1.0E16
 ◇ - 1.0E15

BORON STEAM



A 40

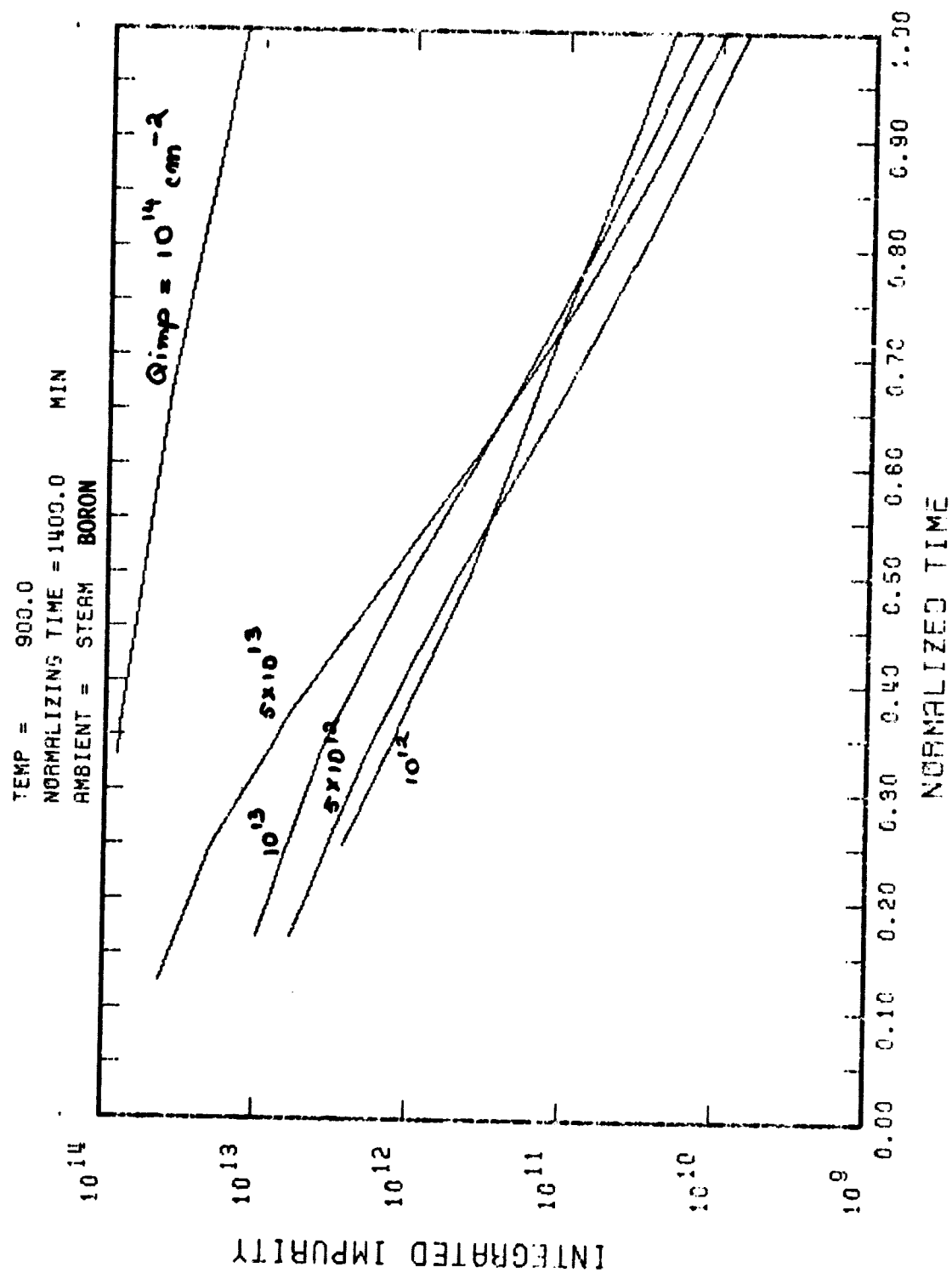


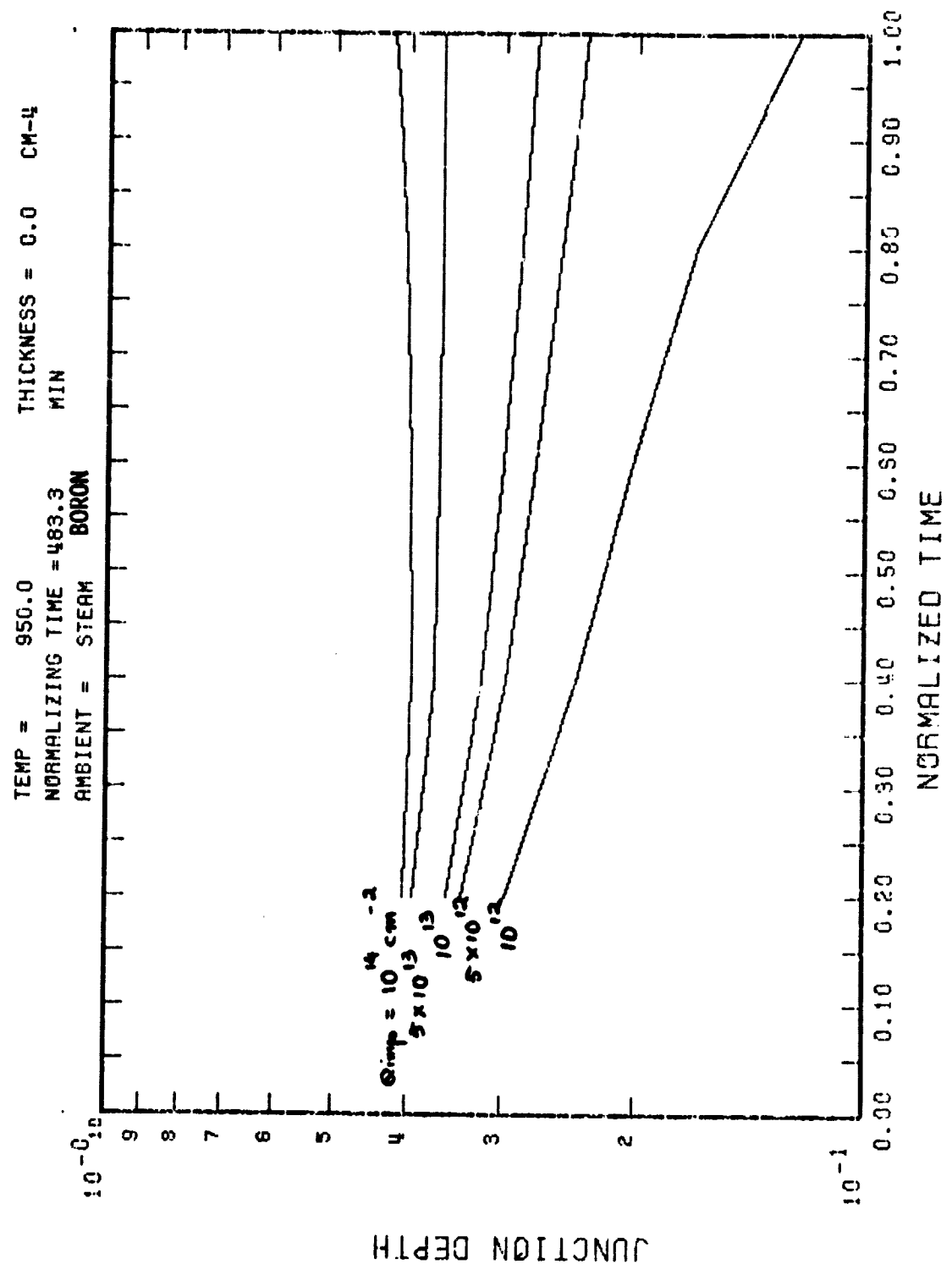


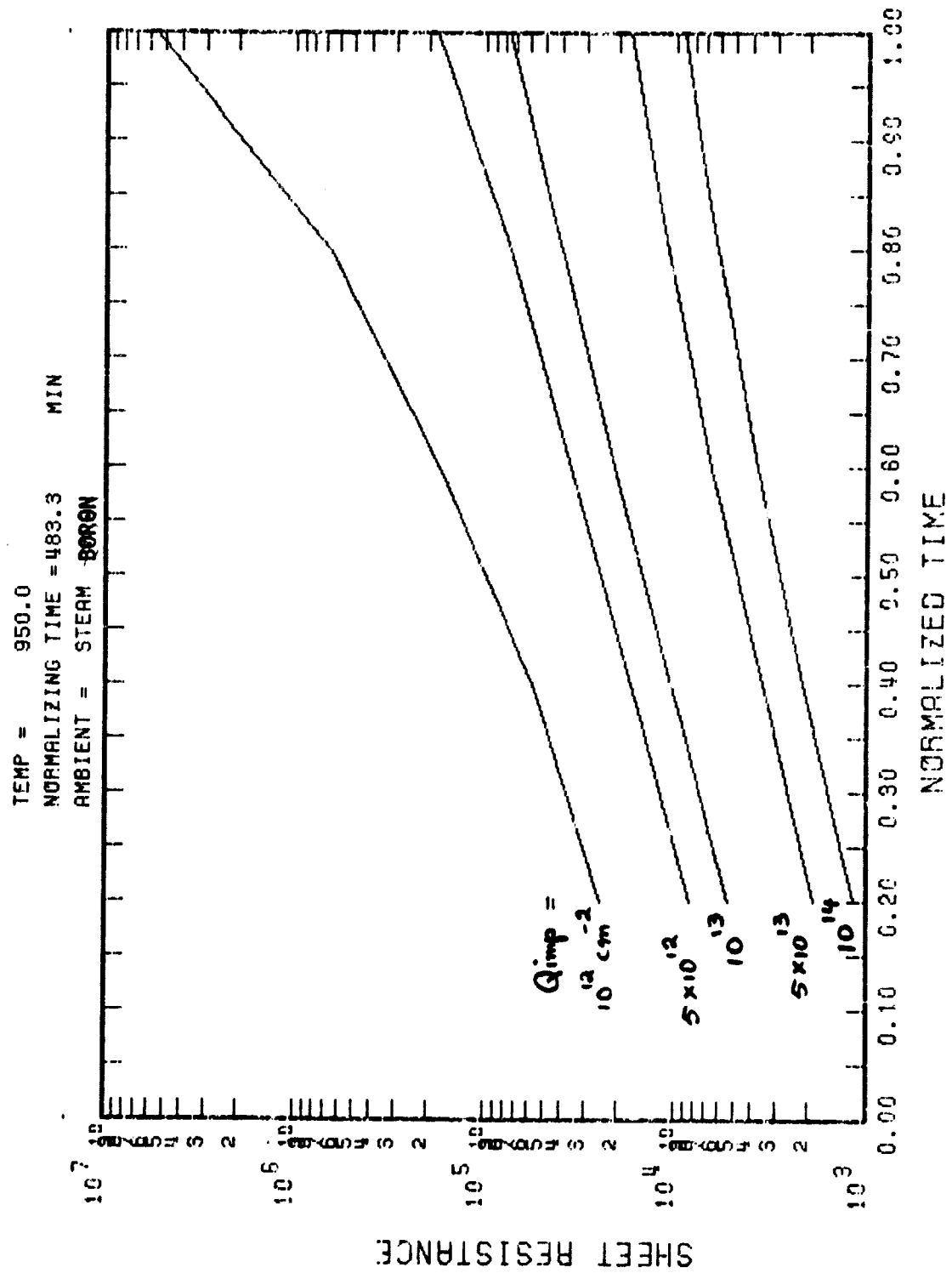
42

ORIGINAL PAGE IS
OF POOR QUALITY

A 42

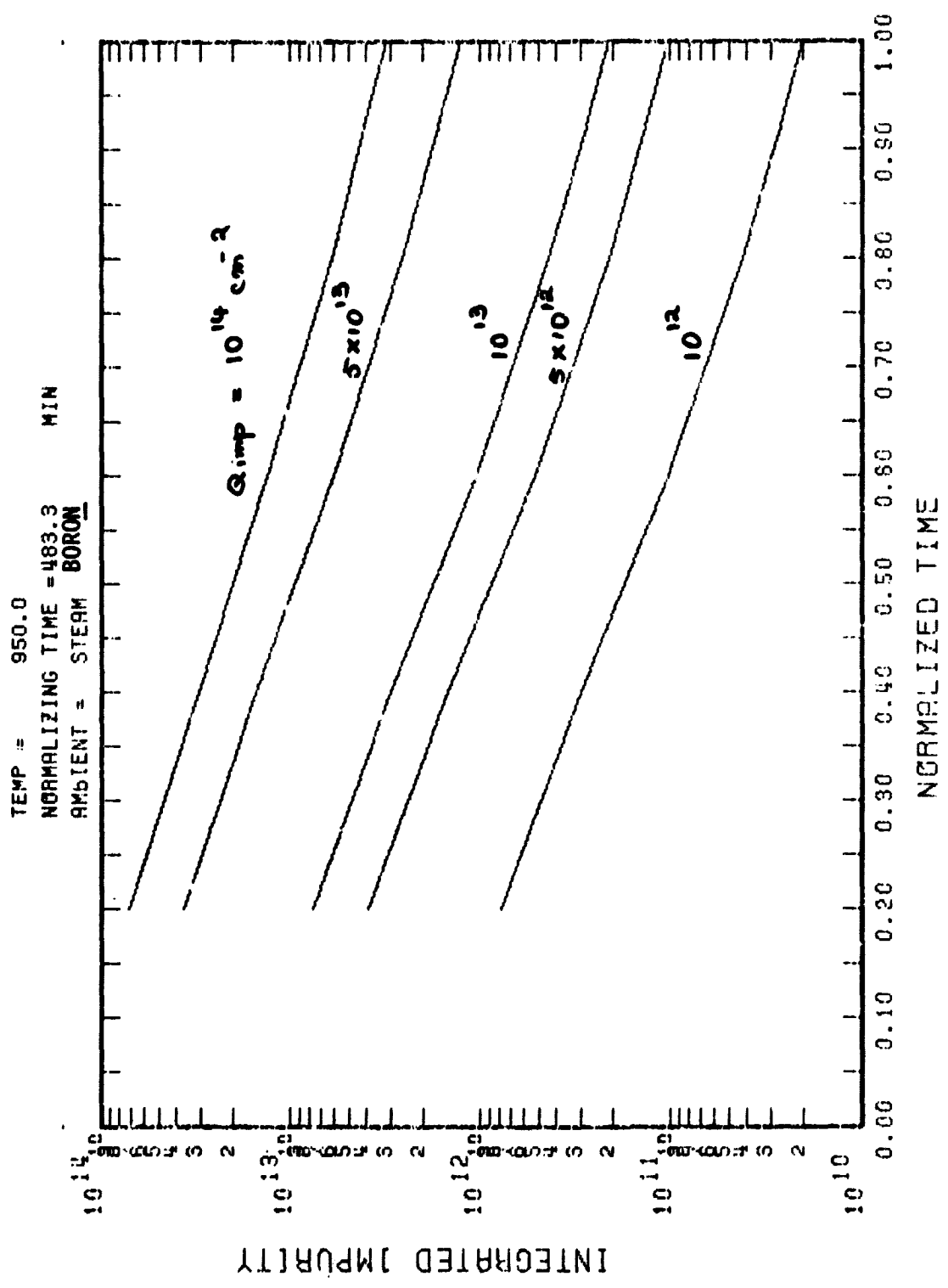






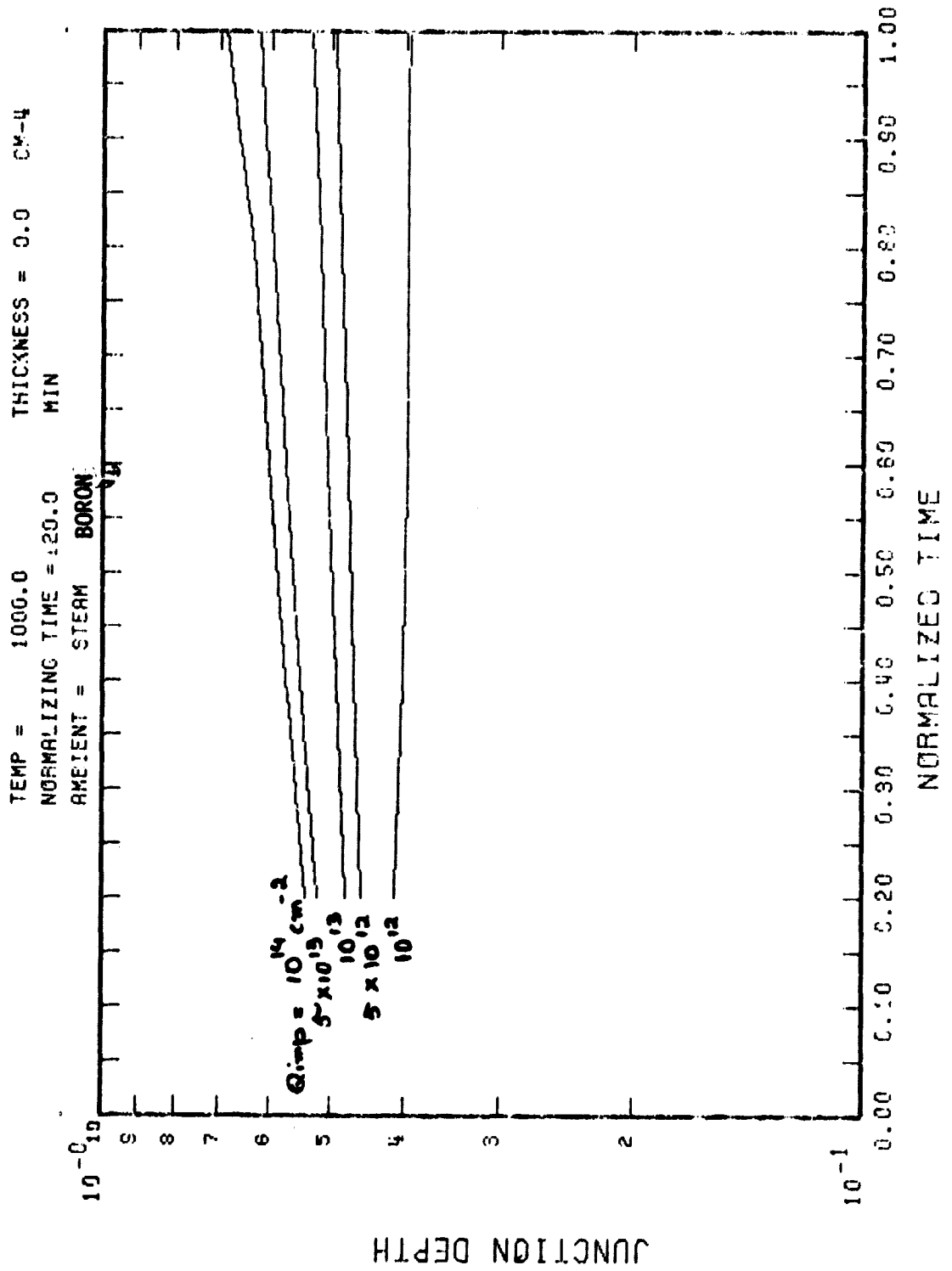
35

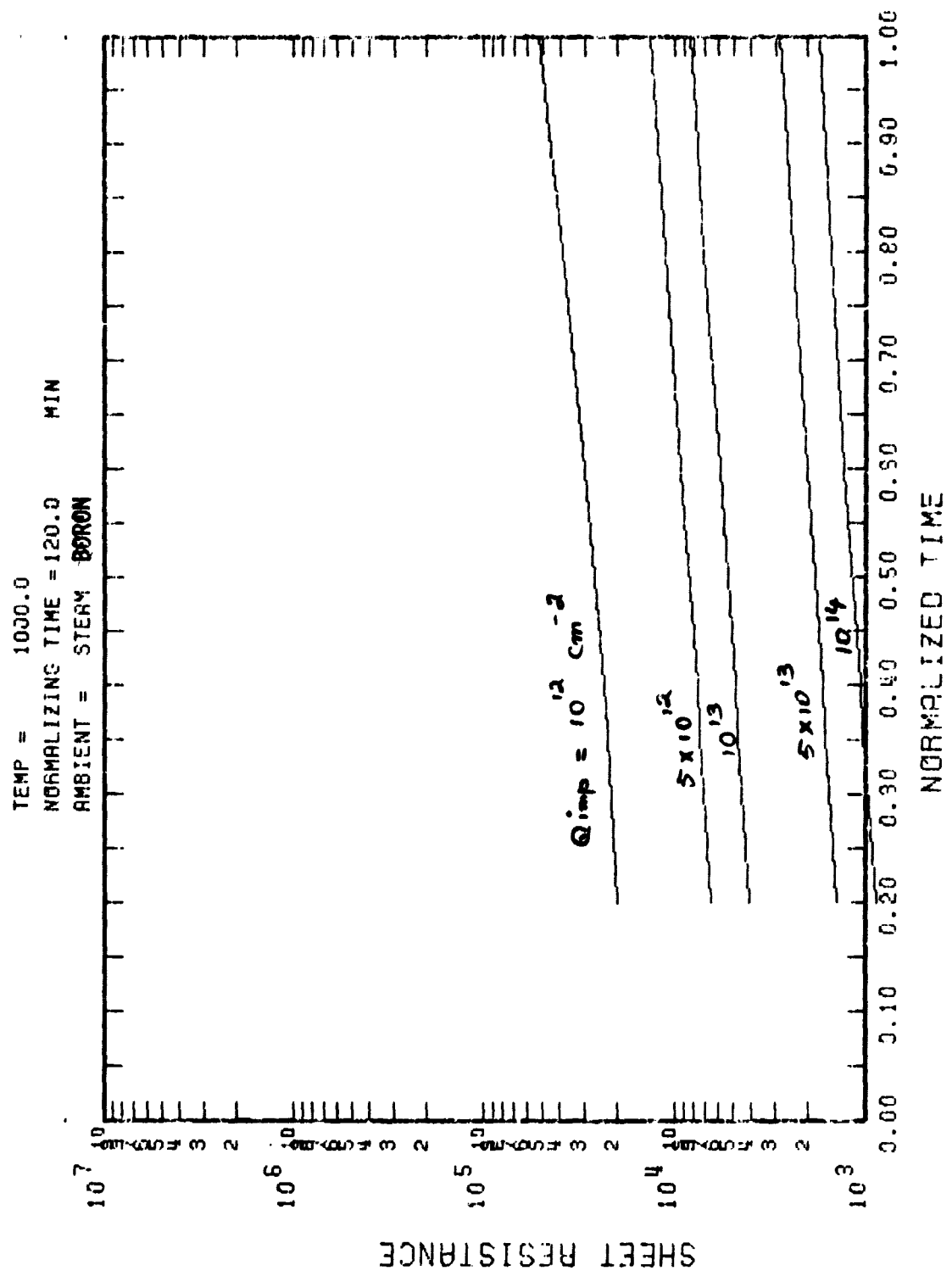
A 45

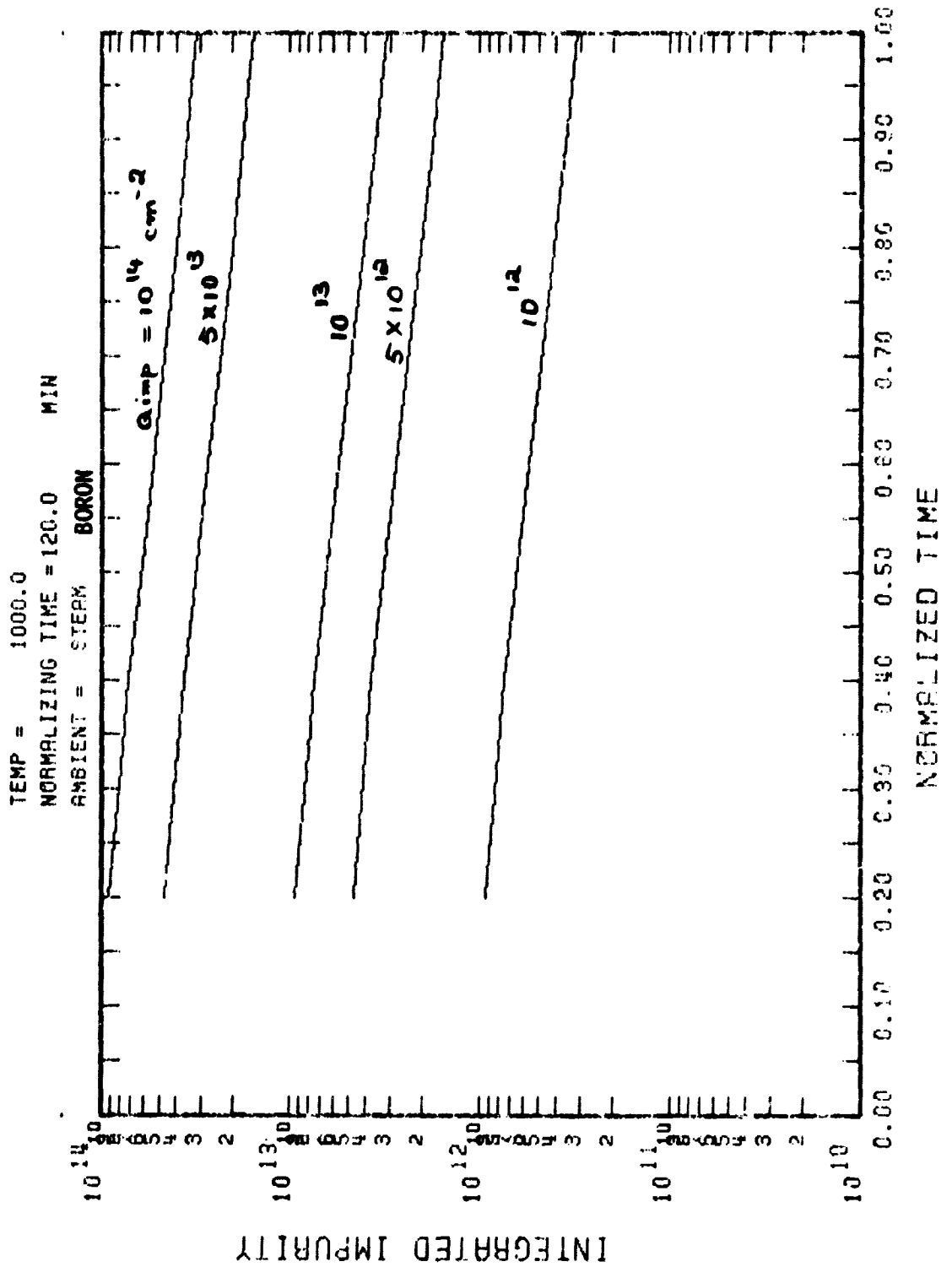


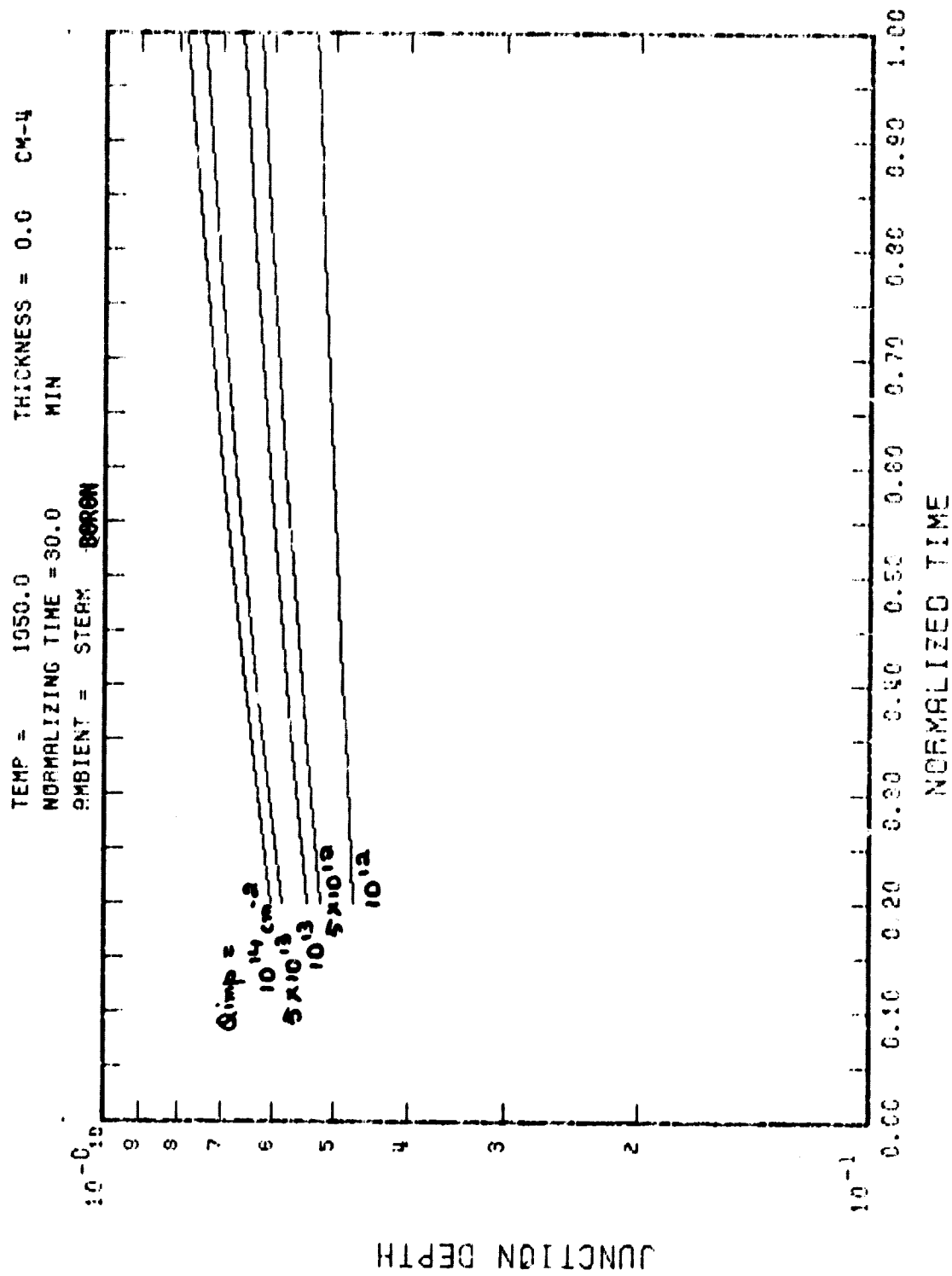
ORIGINAL PAGE IS
OF POOR QUALITY

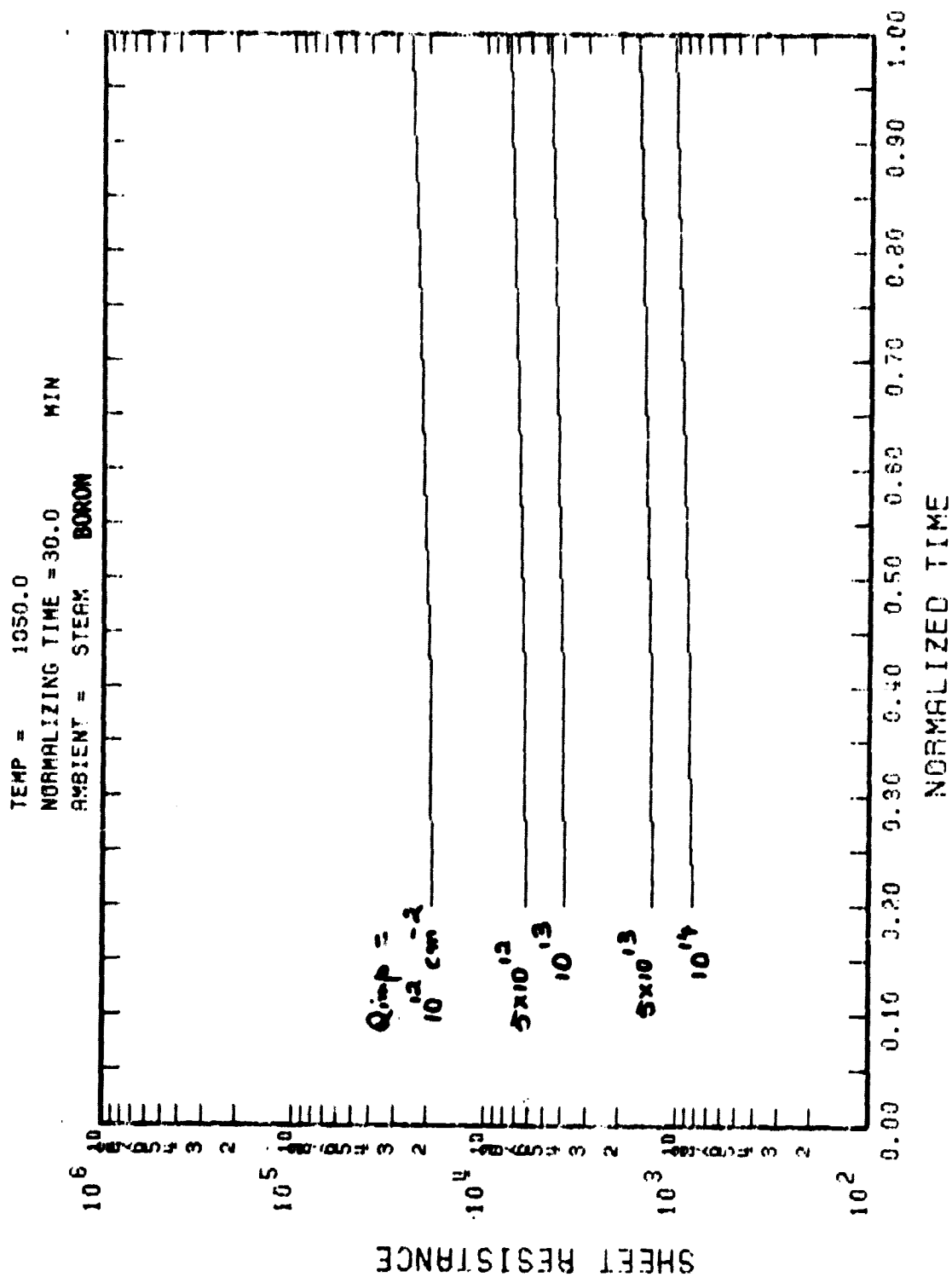
A 46





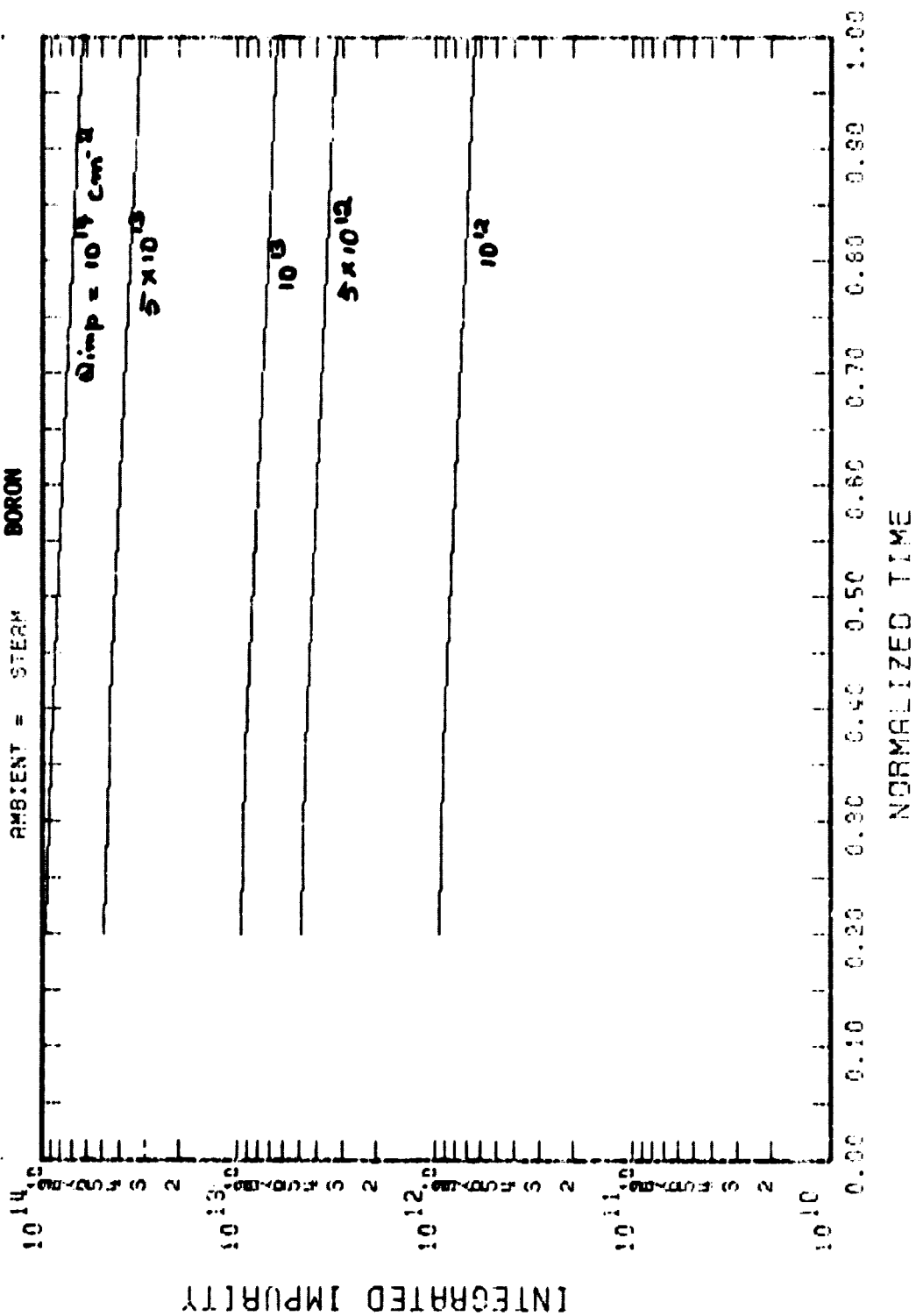






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TEMP = 1050.0
NORMALIZING TIME = 30.0 MIN
AMBIENT = STEAM BORON

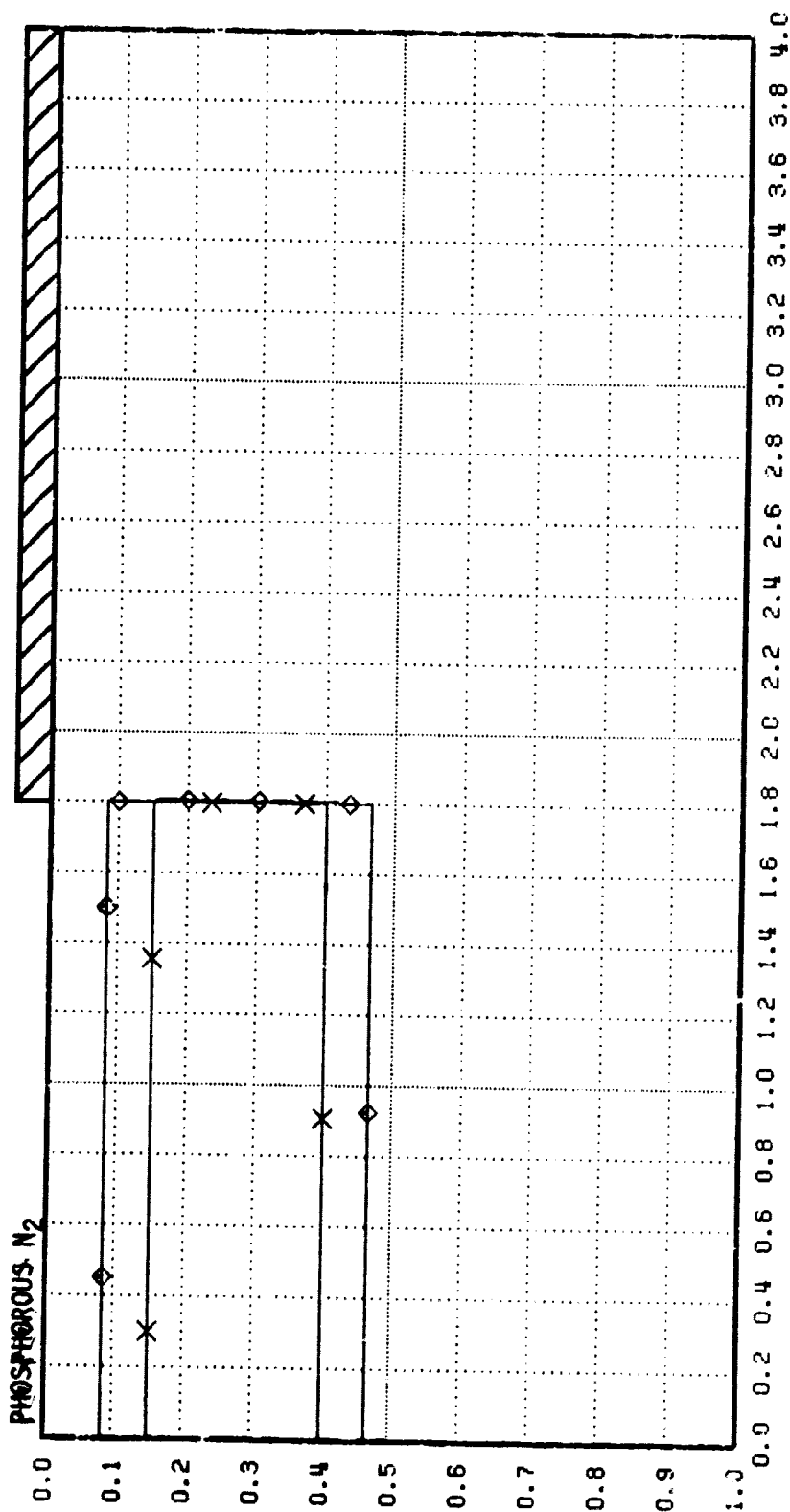


APPENDIX

PHOSPHORUS DATA

λ^2
 TEMPERATURE = 0.0308
 TIME STEP = 1000.
 TIME = 0
 TIME = 0.00

□ - 1.0E20
 ○ - 1.0E19
 ▲ - 1.0E18
 + - 1.0E17
 x - 1.0E16
 ◇ - 1.0E15

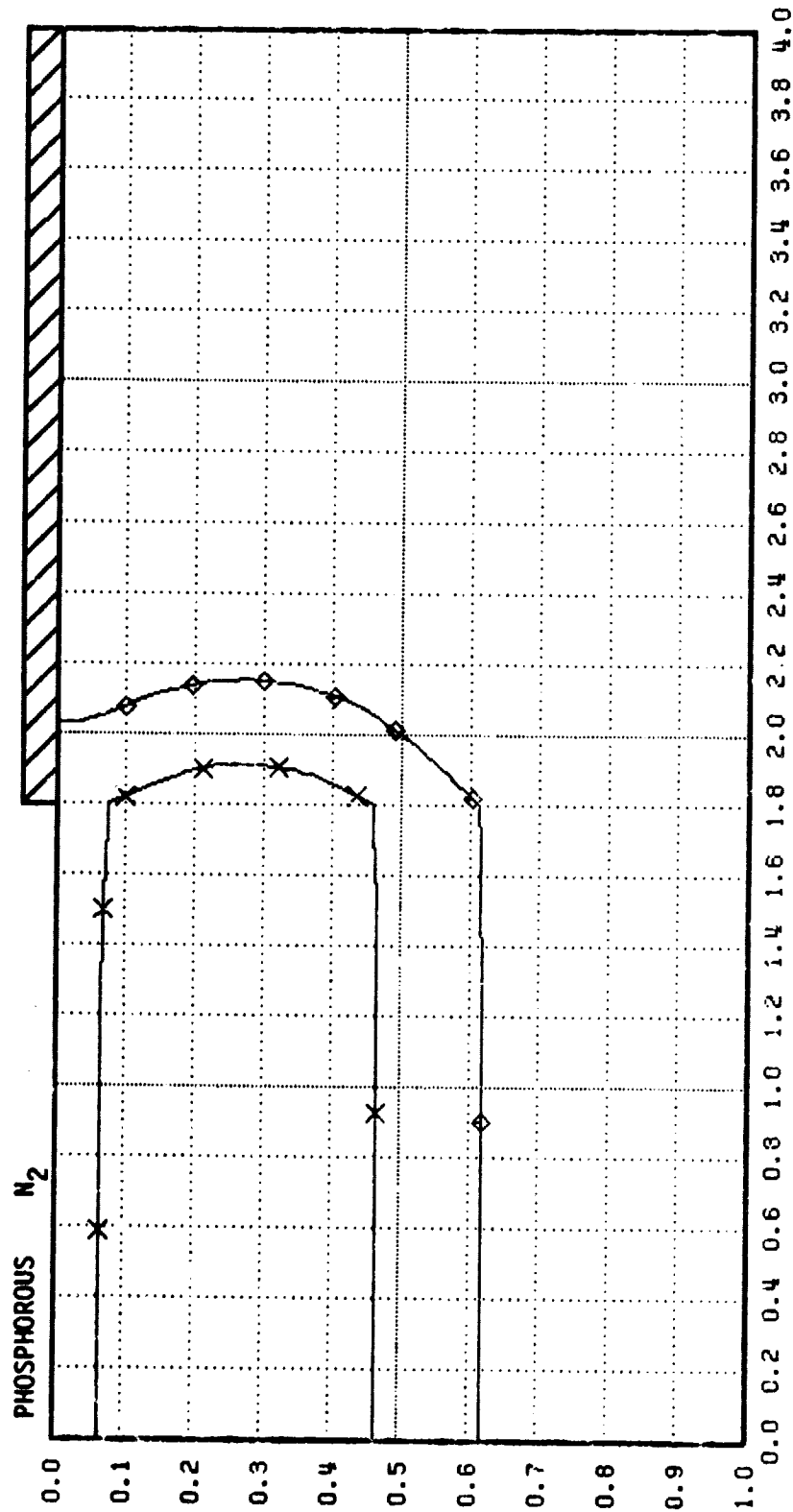


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λ^2
 TEMPERATURE
 TIME STEP
 TIME

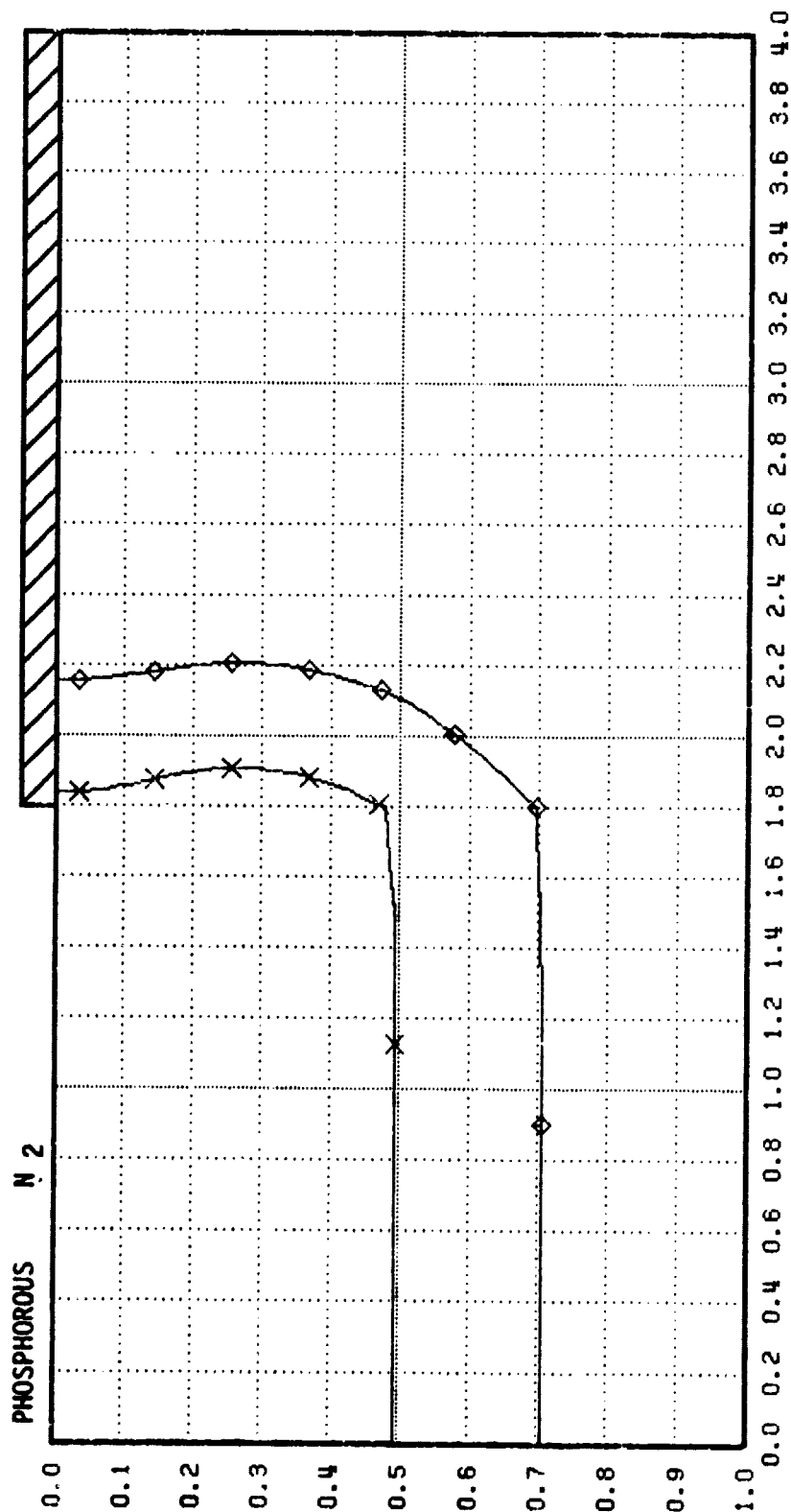
= 0.0308
 = 1000.
 = 10
 = 0.20

- 1.0E20
 - 1.0E19
 - 1.0E18
 - 1.0E17
 - 1.0E16
 - 1.0E15



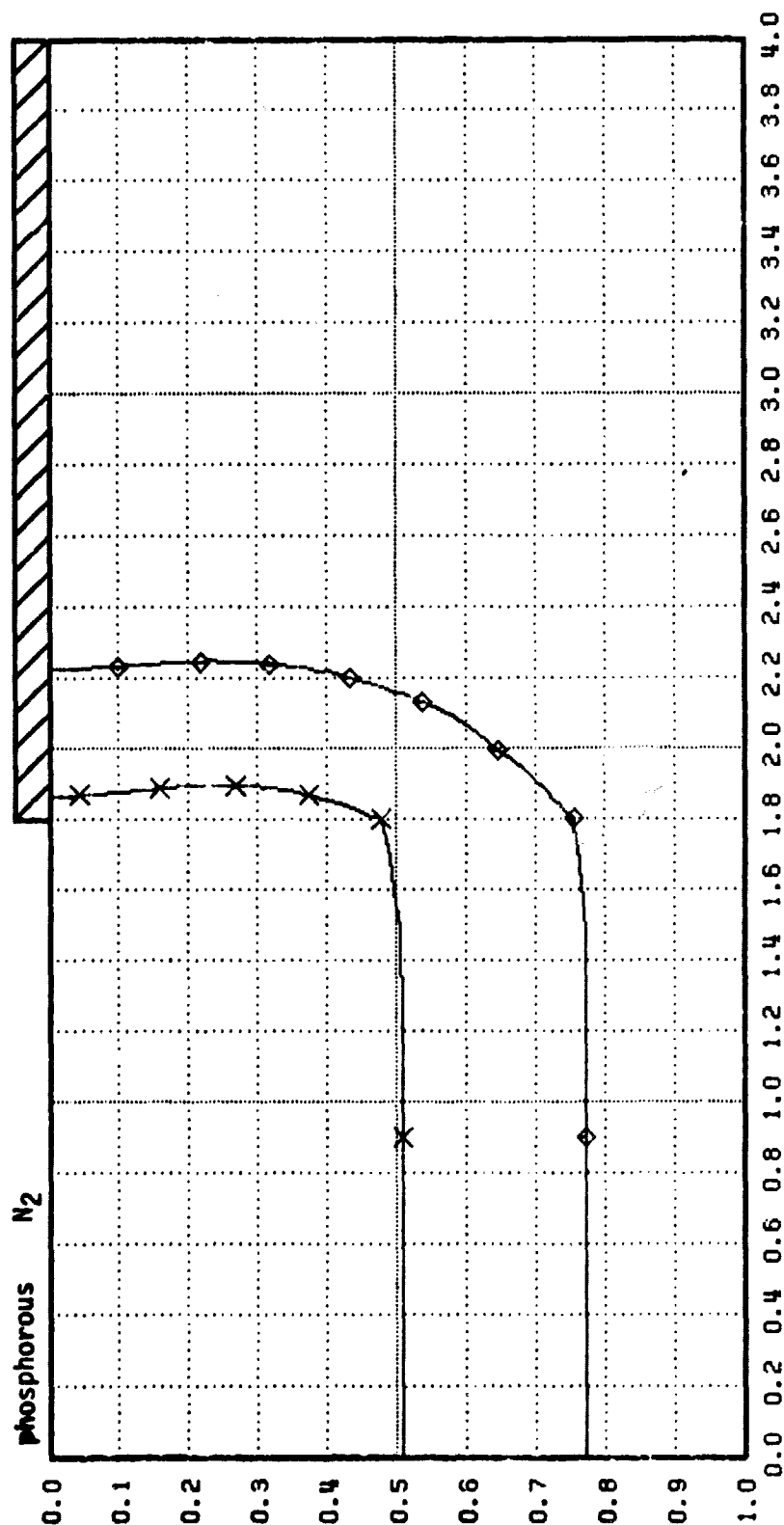
λ^2
 TEMPERATURE = 0.0308
 TIME STEP = 1000.
 TIME = 20
 TIME = 0.40

□ - 1.0E20
 ○ - 1.0E19
 △ - 1.0E18
 + - 1.0E17
 × - 1.0E16
 ◇ - 1.0E15



λ^2
 TEMPERATURE = 0.0308
 TIME STEP = 1000.
 TIME = 30
 TIME = 0.60

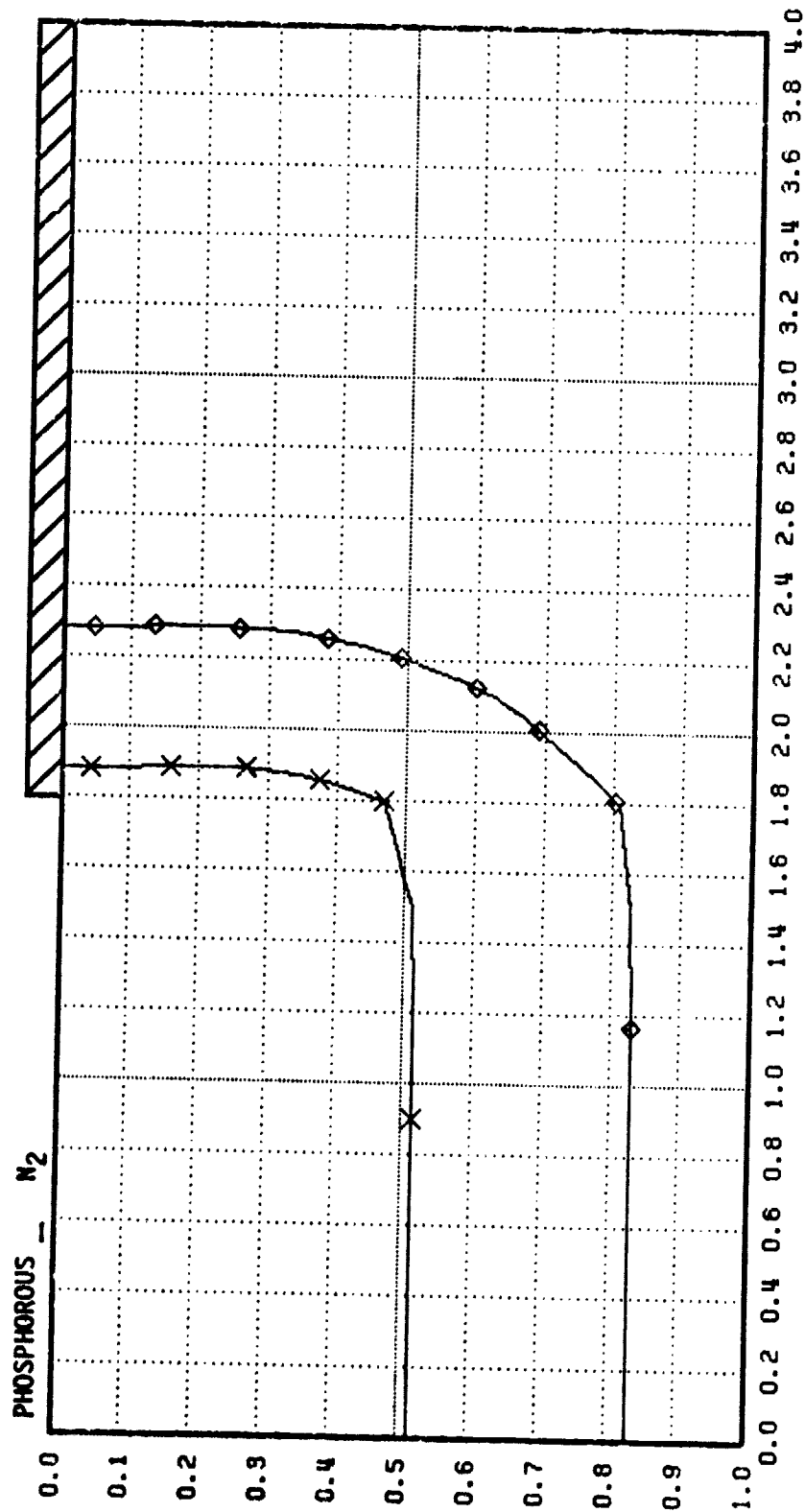
□ - 1.0E20
 ○ - 1.0E19
 △ - 1.0E18
 + - 1.0E17
 × - 1.0E16
 ◇ - 1.0E15



λ^2
 TEMPERATURE
 TIME STEP
 TIME

= 0.0308
 = 1000.
 = 40
 = 0.80

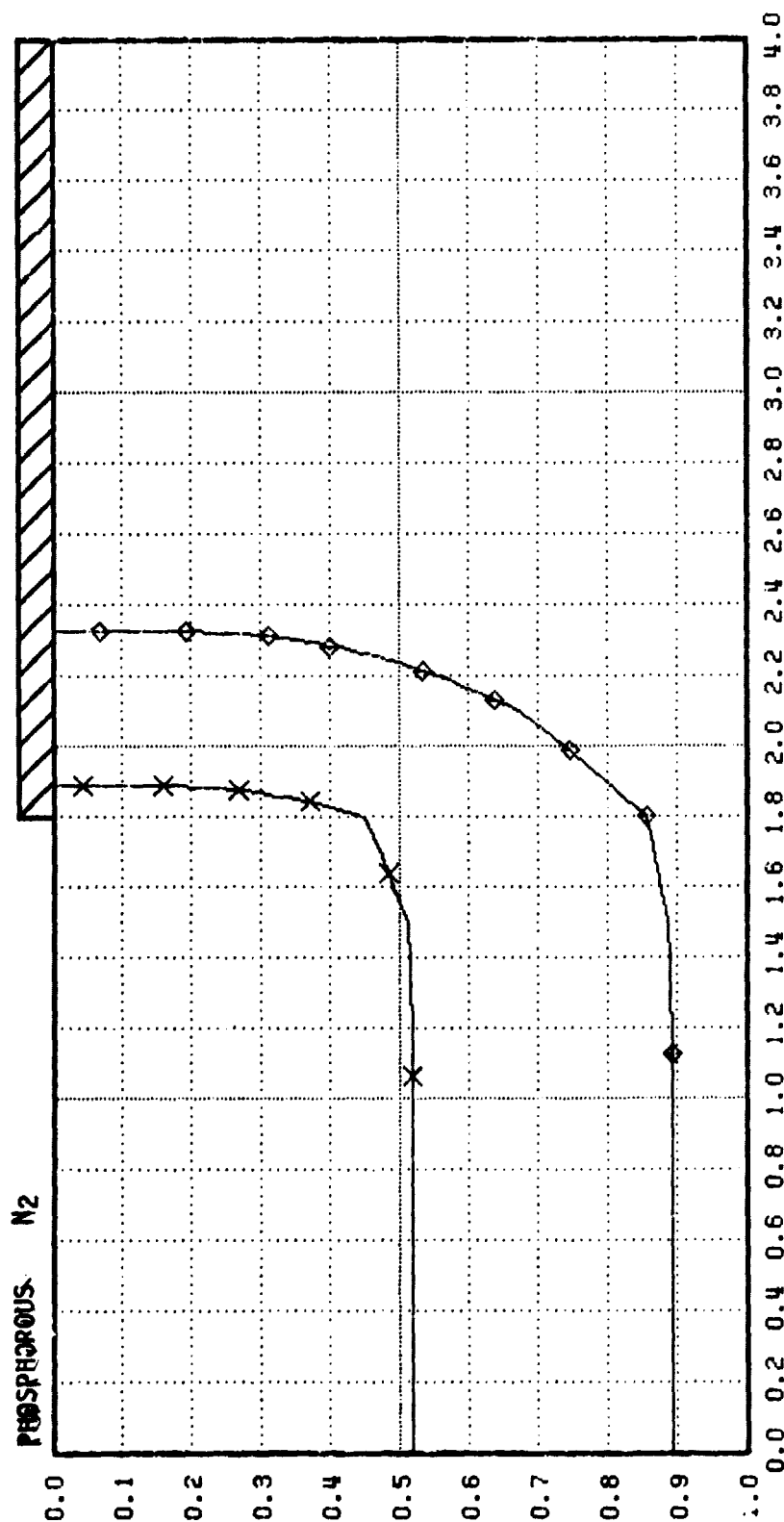
□ - 1.0E20
 ○ - 1.0E19
 △ - 1.0E18
 + - 1.0E17
 × - 1.0E16
 ◇ - 1.0E15

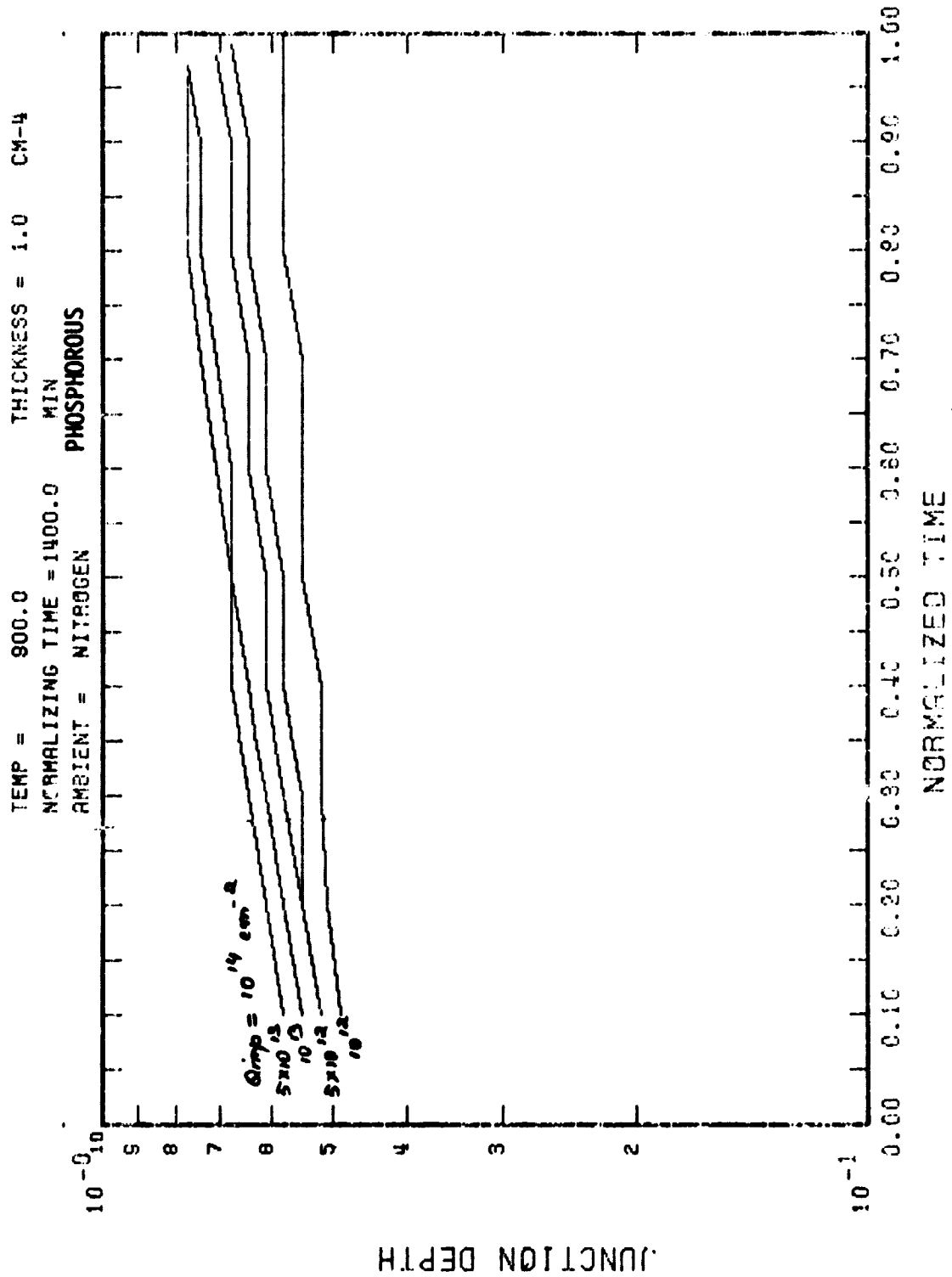


λ^2
 TEMPERATURE
 TIME STEP
 TIME

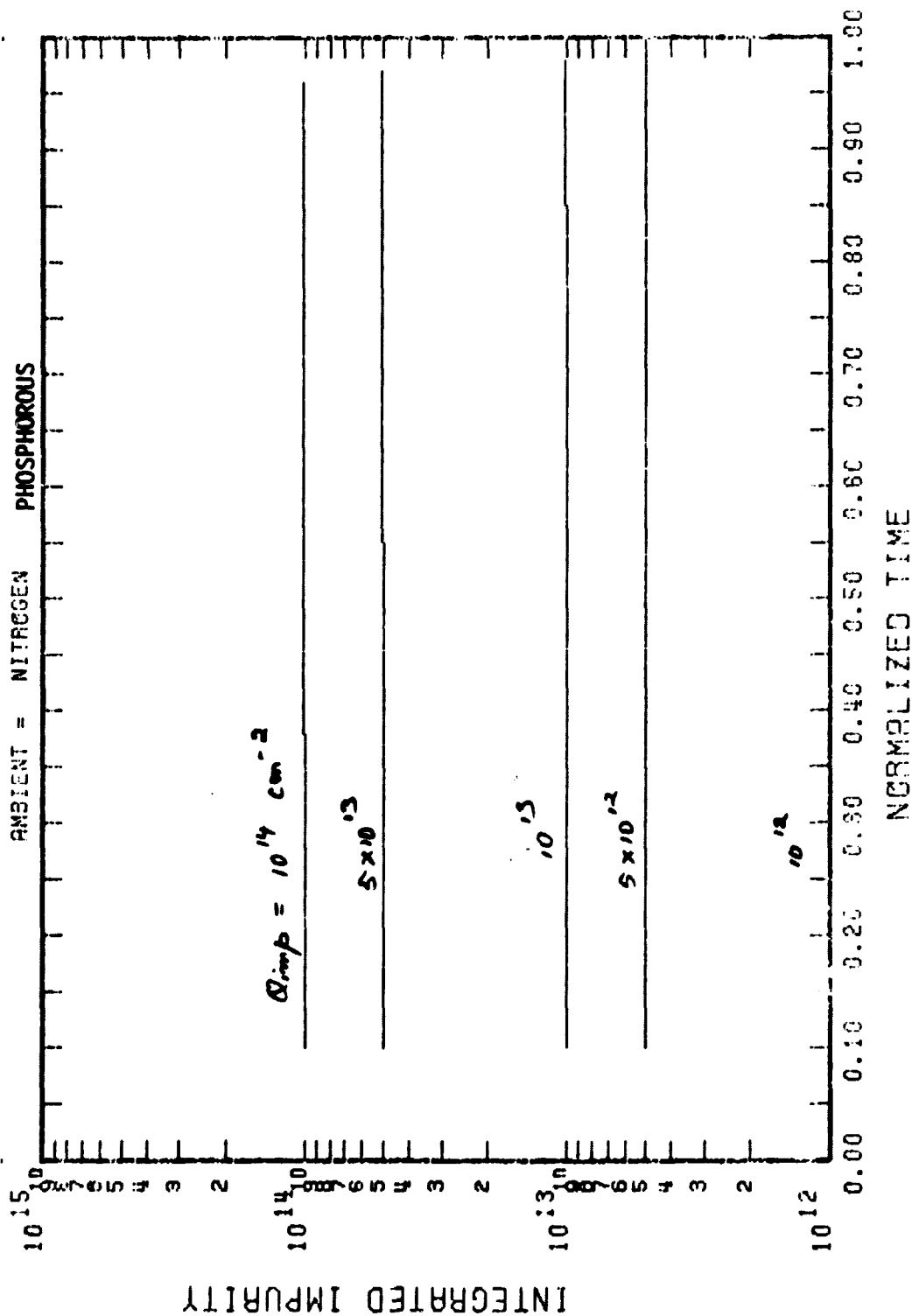
= 0.0308
 = 1000.
 = 50
 = 1.00

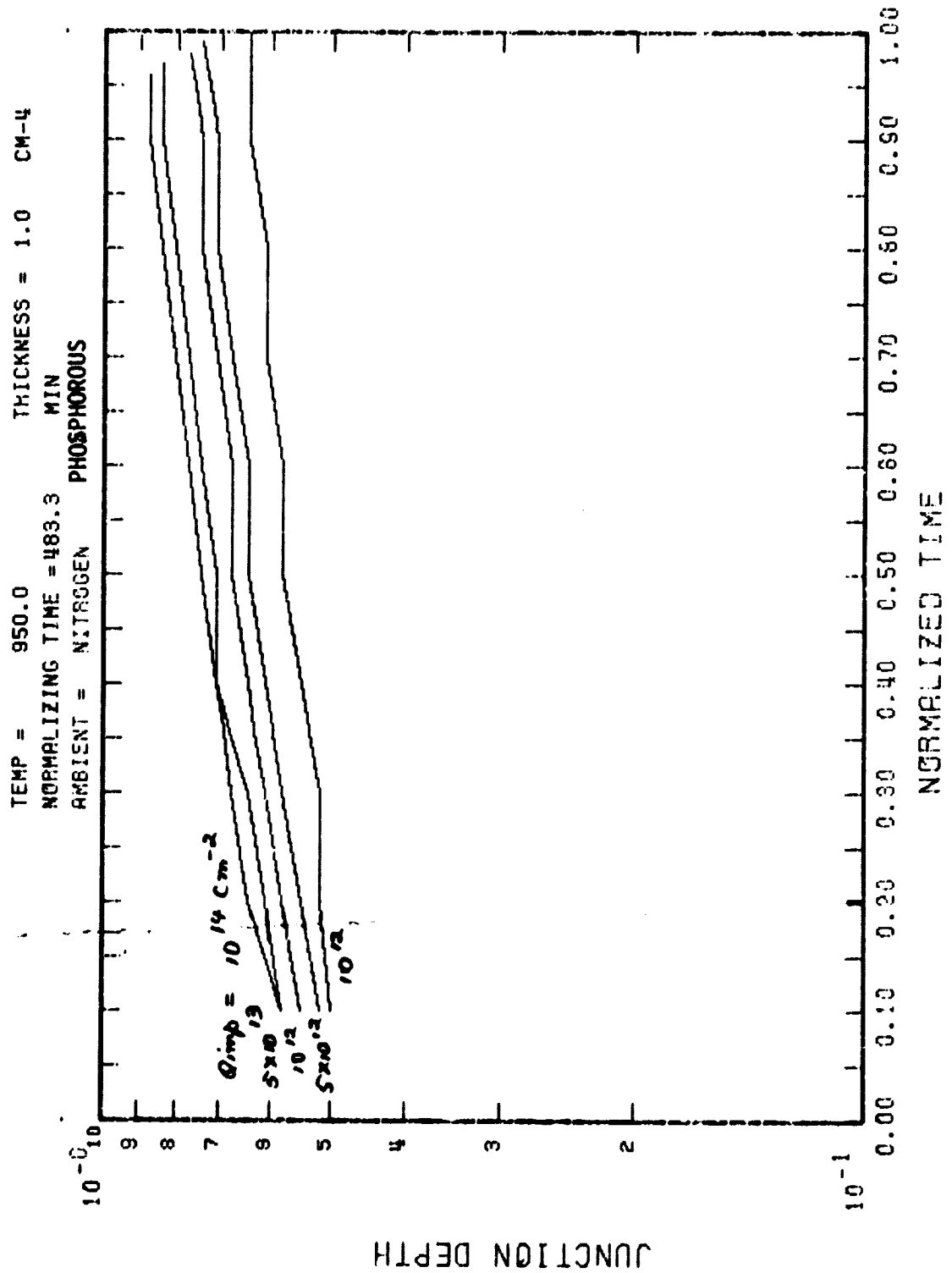
□ - 1.0E20
 ○ - 1.0E19
 △ - 1.0E18
 + - 1.0E17
 × - 1.0E16
 ◇ - 1.0E15

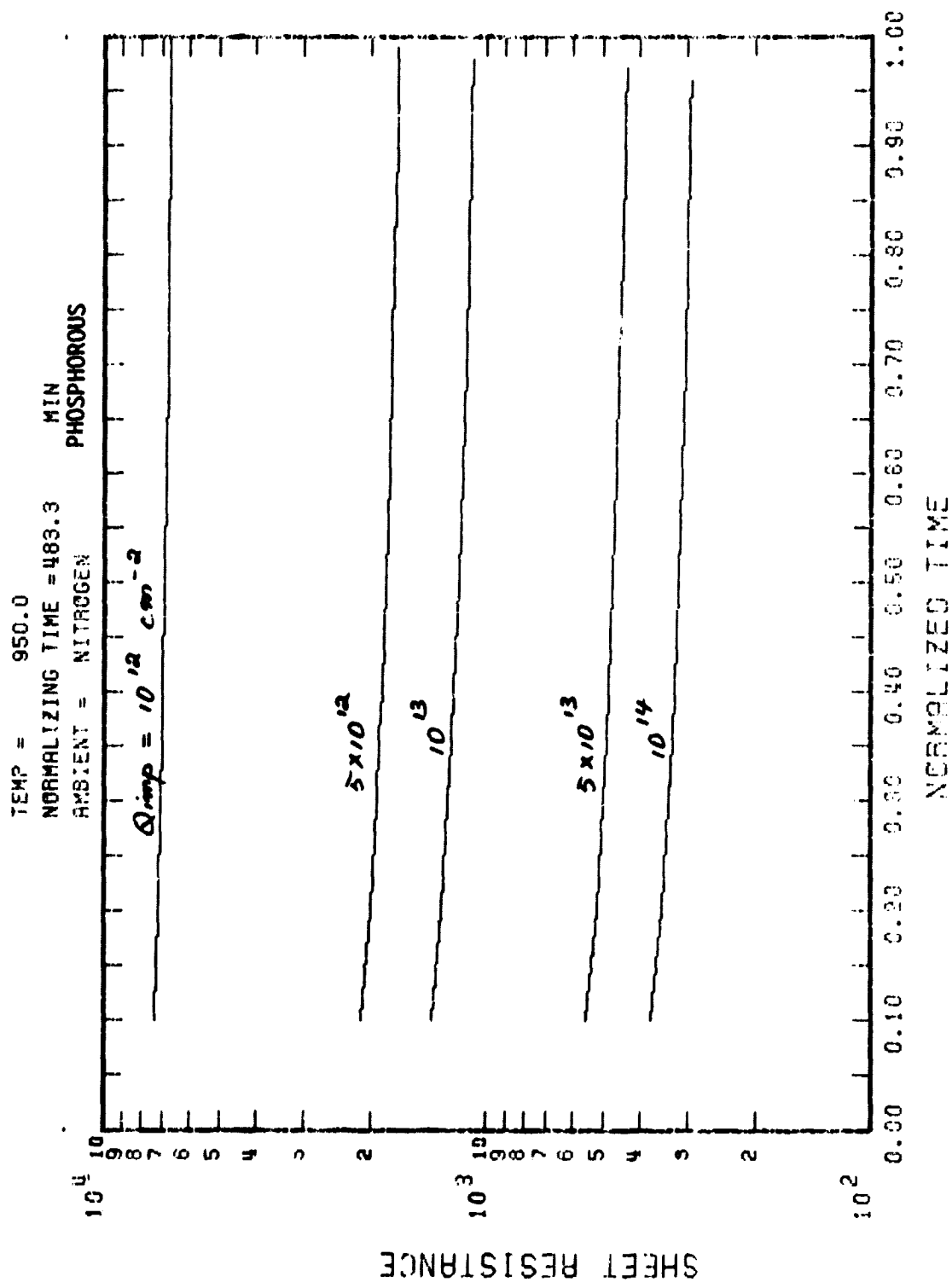


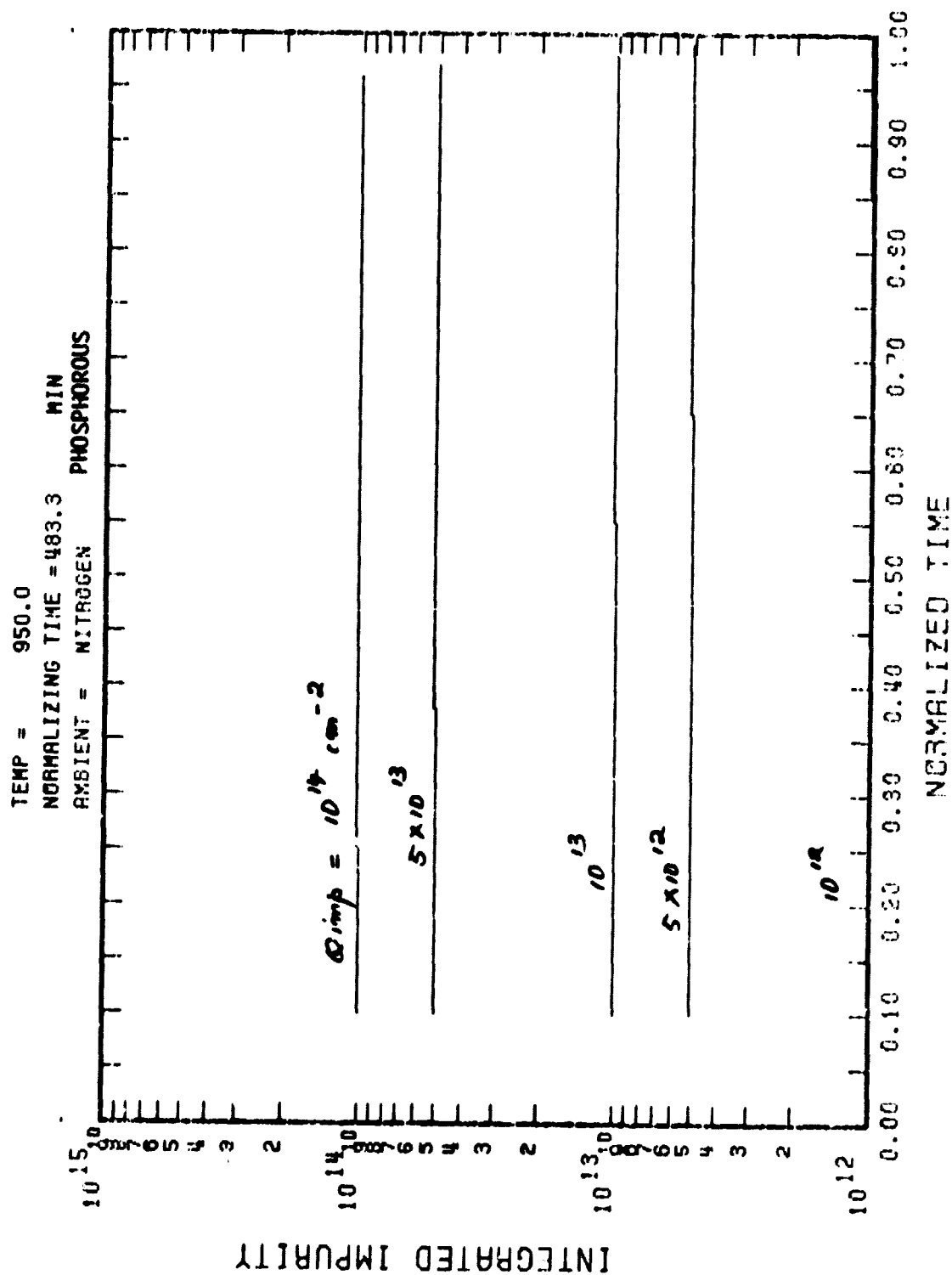


TEMP = 900.0
 NORMALIZING TIME = 1400.0 MIN
 AMBIENT = NITROGEN PHOSPHOROUS

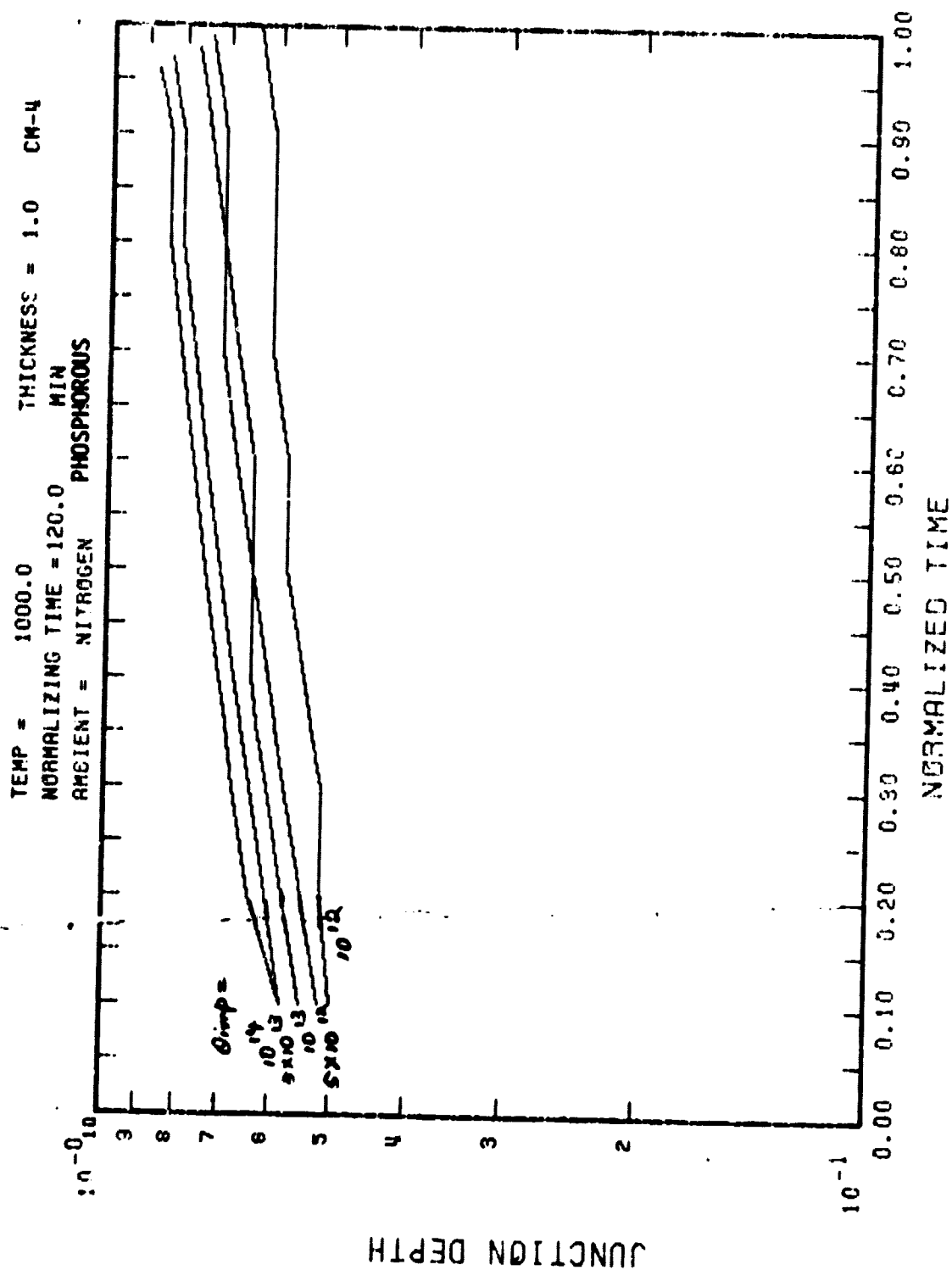


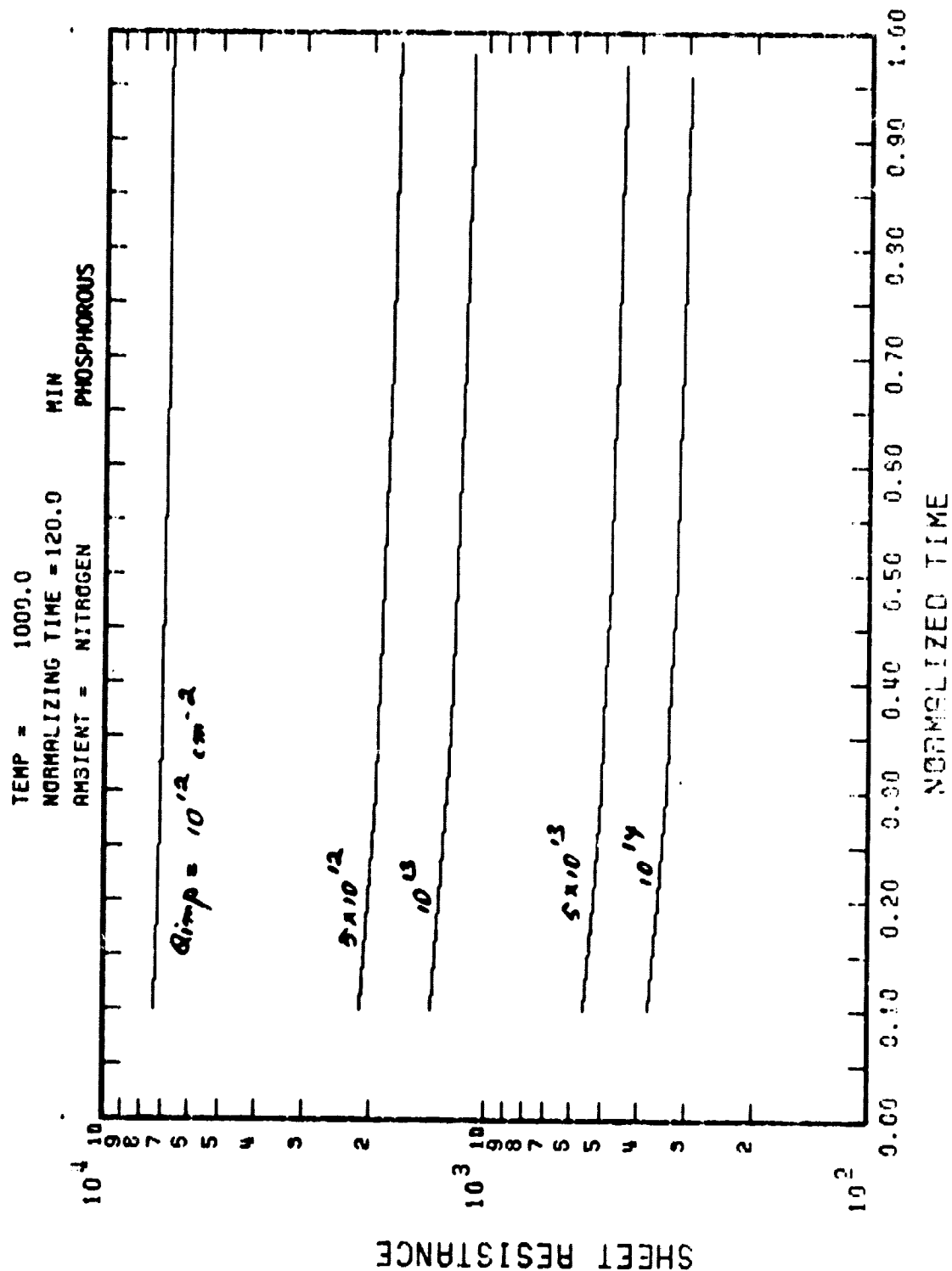




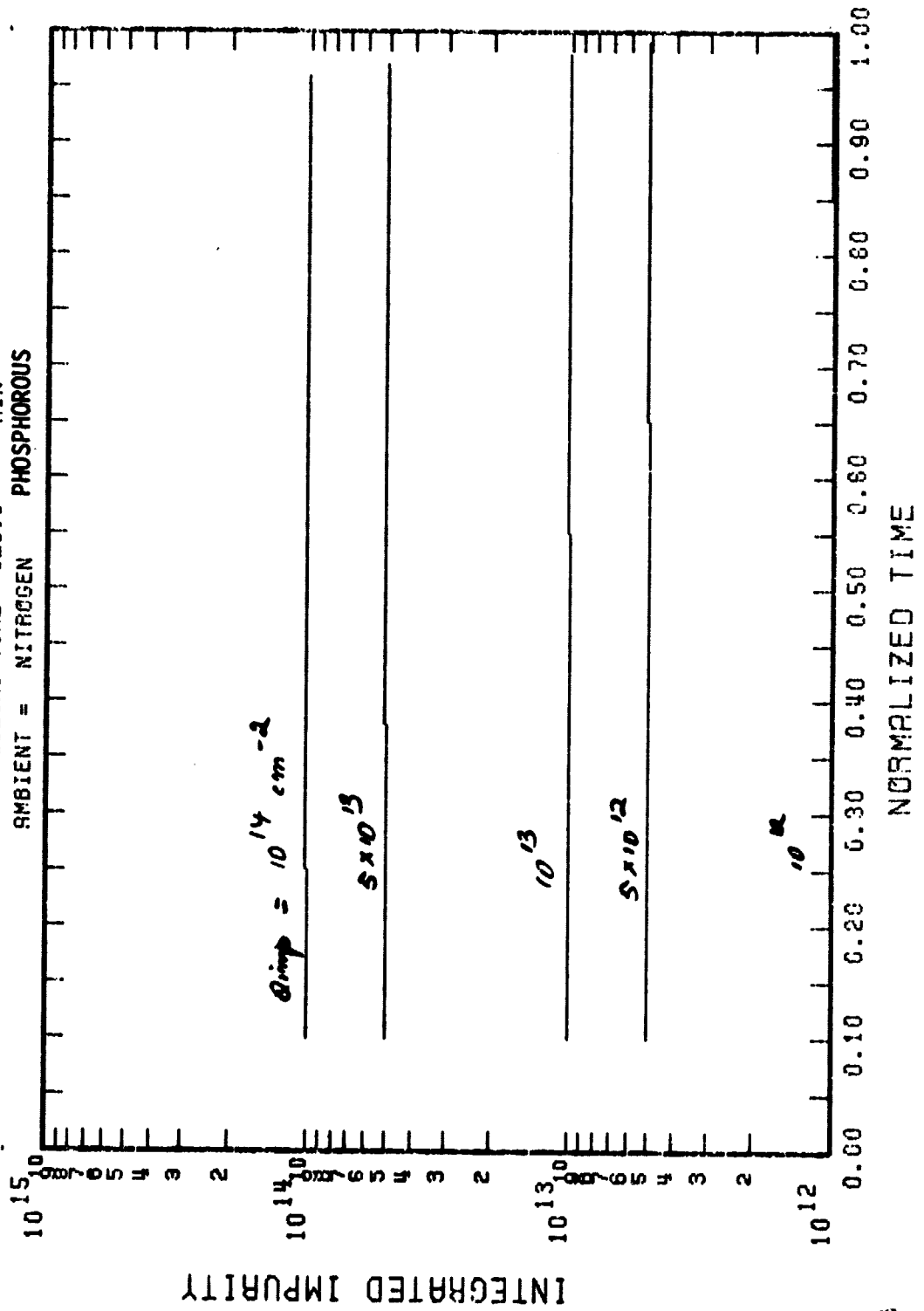


C. 2



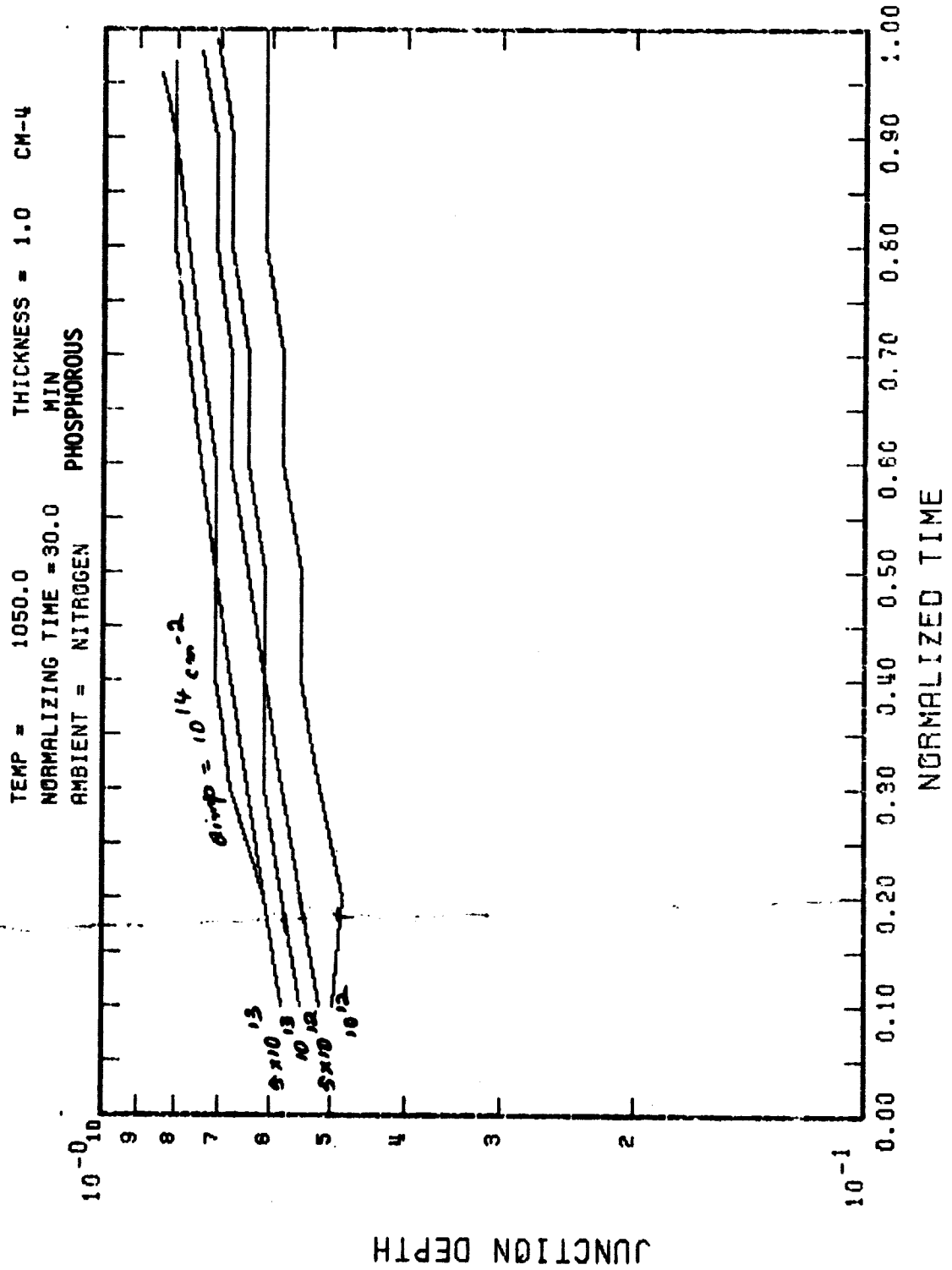


TEMP = 1000.0
 NORMALIZING TIME = 120.0 MIN
 AMBIENT = NITROGEN PHOSPHOROUS

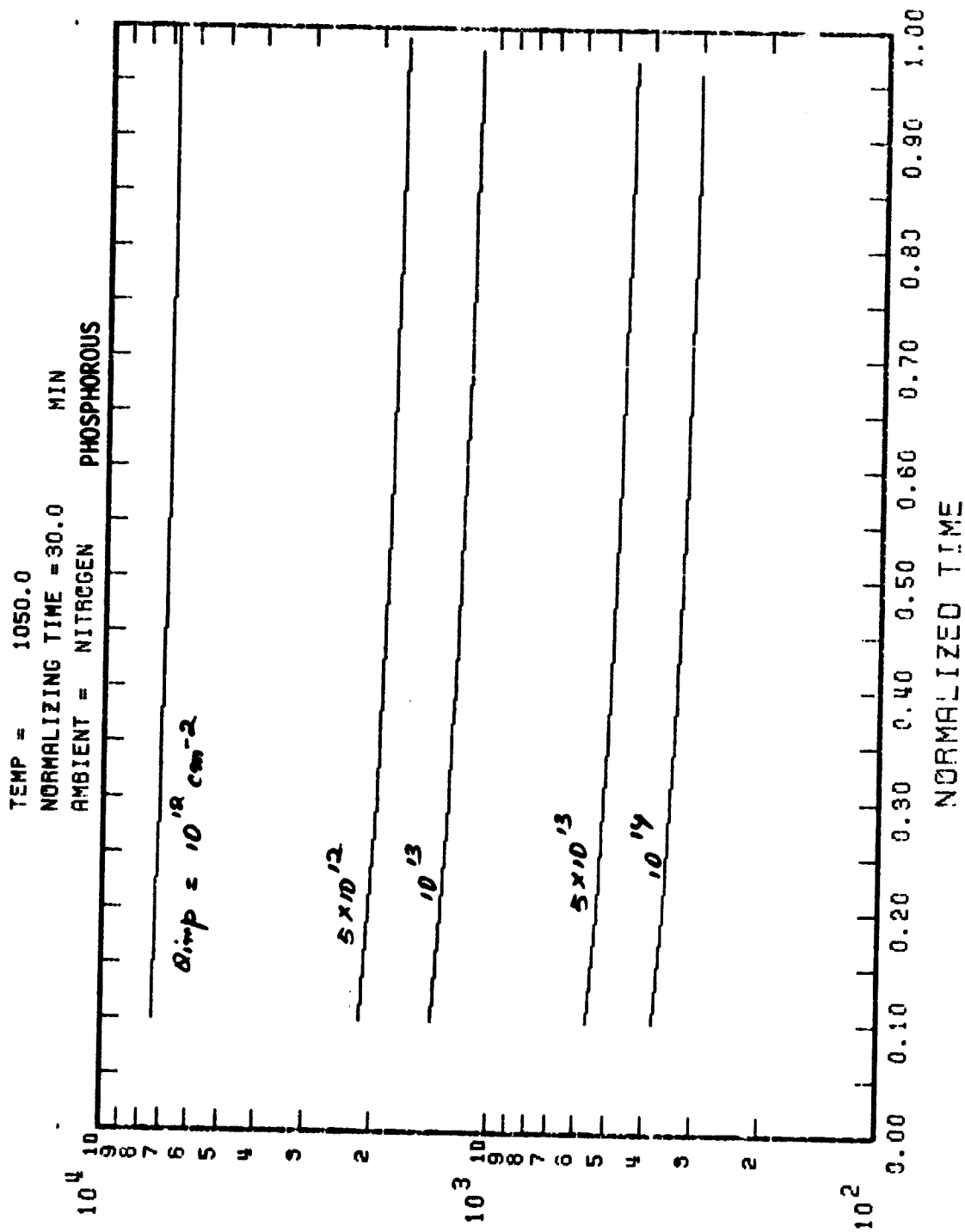


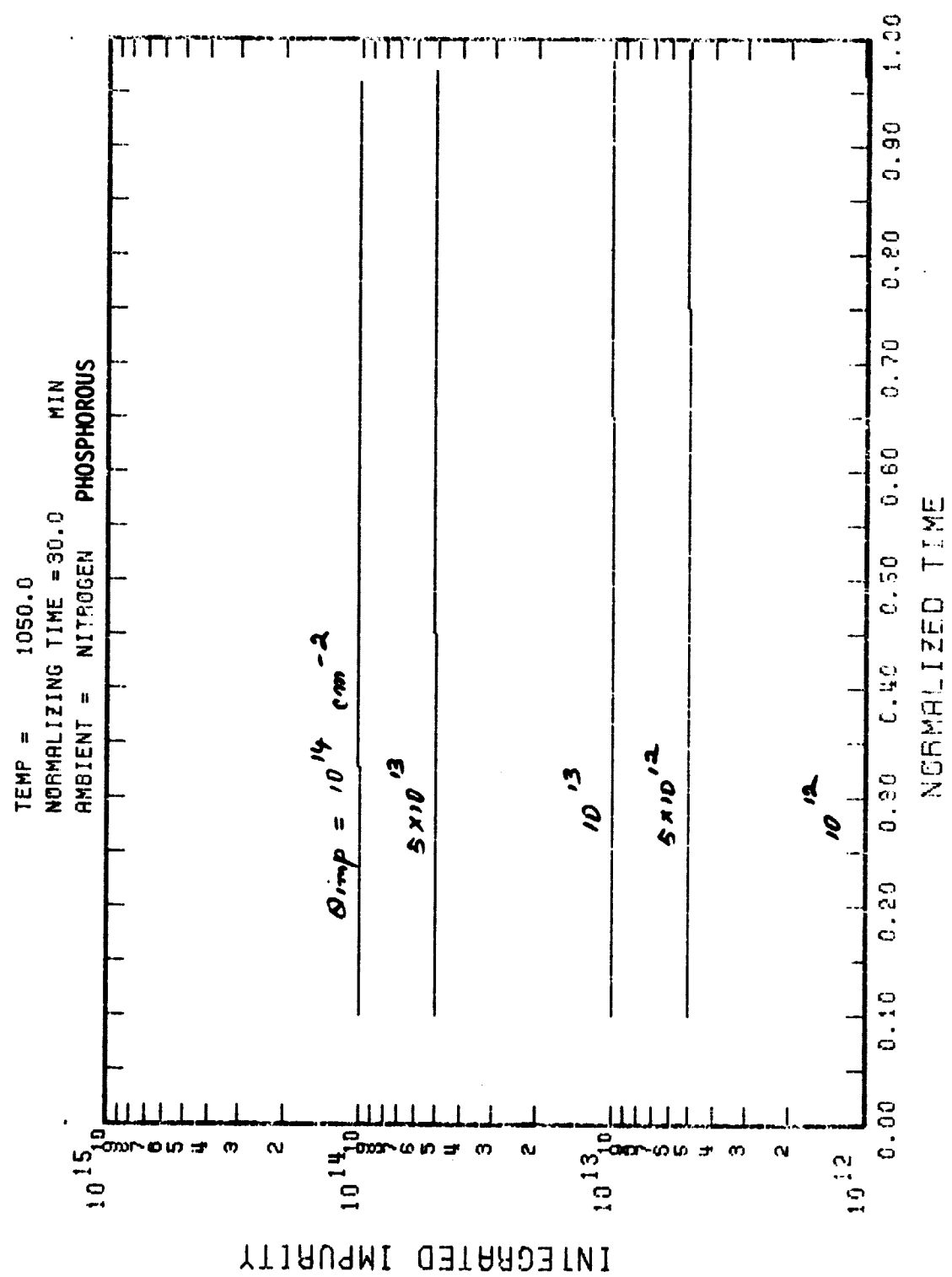
C-2

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SHEET RESISTANCE



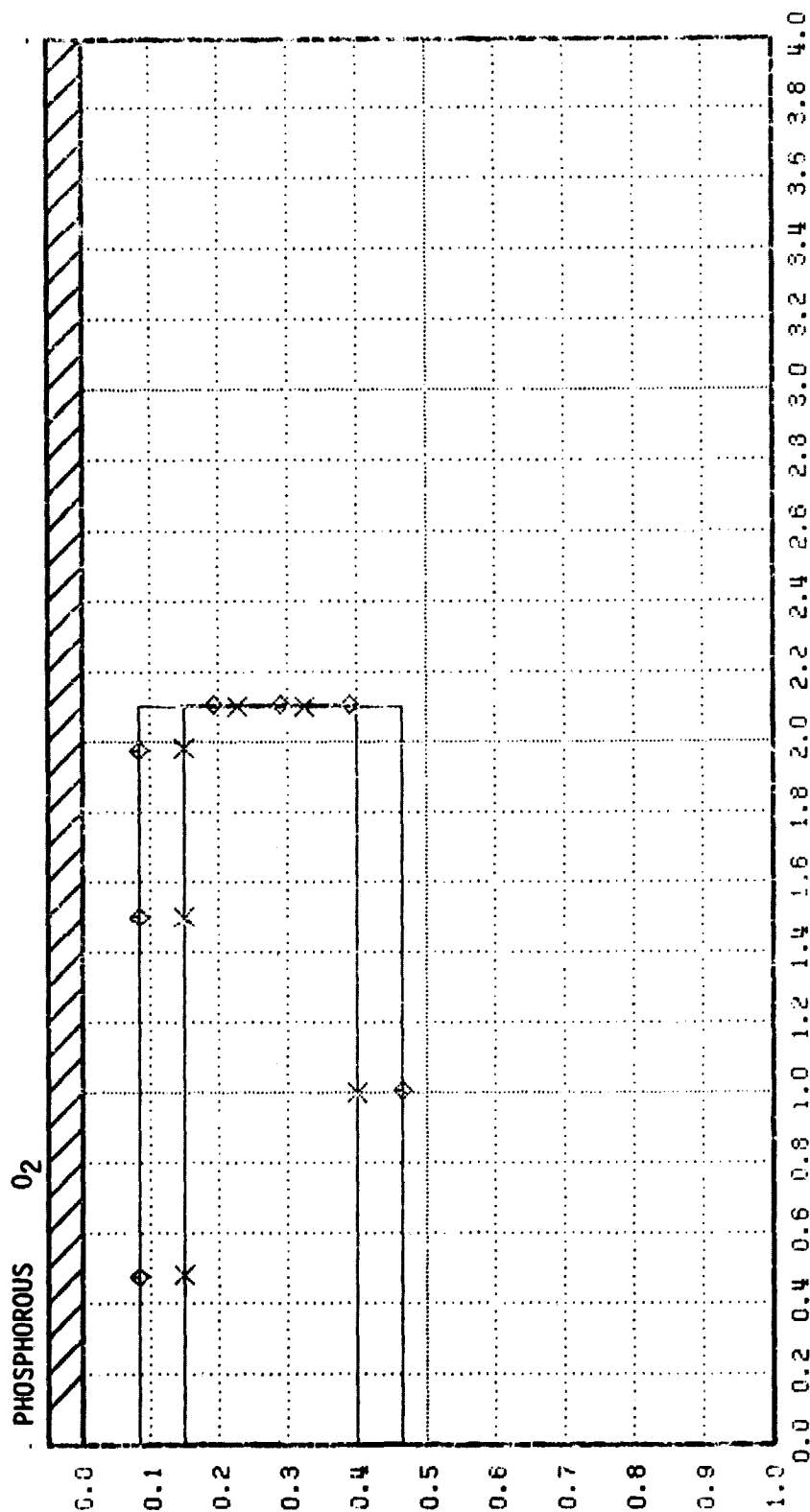


χ^2
 TEMPERATURE
 TIME STEP
 TIME

= 0.0000
 = 1000.
 = 0
 = 0.00

- 1.0E20
 - 1.0E19
 - 1.0E18
 - 1.0E17
 - 1.0E16
 - 1.0E15

□ 0
 4
 +
 x
 ◇



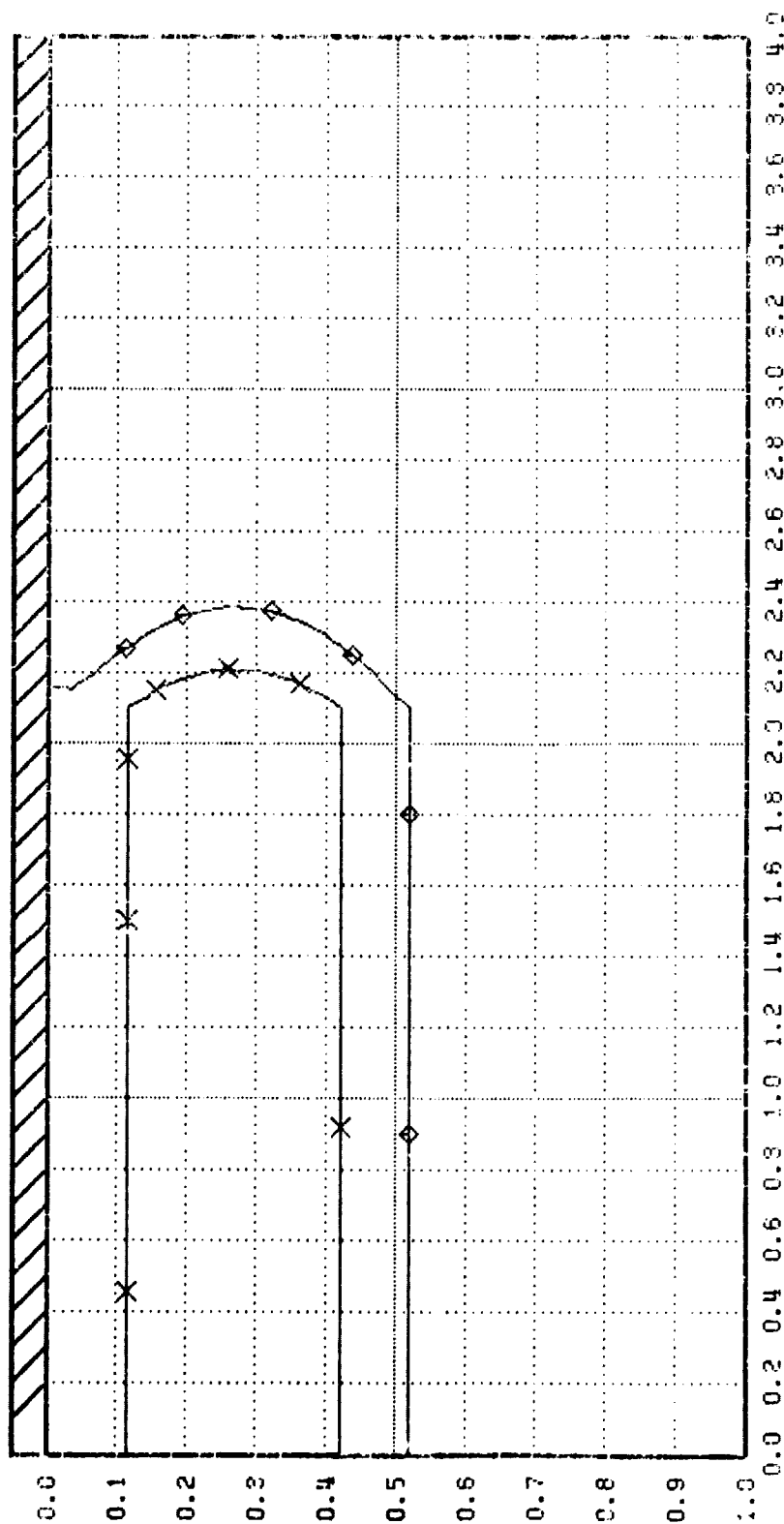
ORIGINAL PAGE IS
OF POOR QUALITY

B 20

λ^2
 TEMPERATURE
 TIME STEP
 TIME
 PHOSPHOROUS O_2

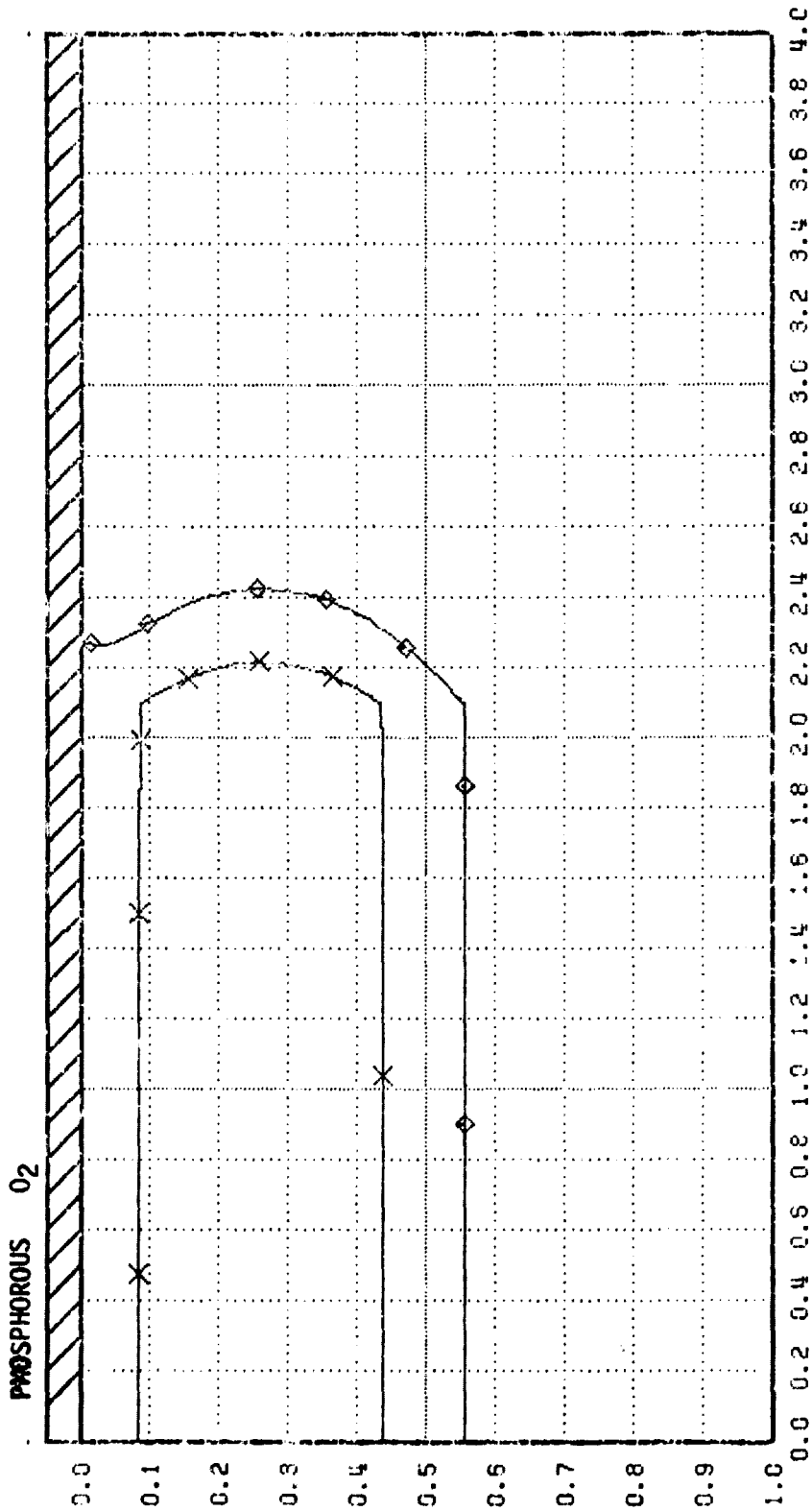
= 0.0000
 = 1000.
 = 20
 = 1440.00

- 1.0E20
 - 1.0E19
 - 1.0E18
 - 1.0E17
 - 1.0E16
 - 1.0E15



χ^2
 TEMPERATURE = 0.0000
 TIME STEP = 1000.
 TIME = 40
 TIME = 2880.00

E 1.0E20
 1.0E19
 1.0E18
 1.0E17
 1.0E16
 1.0E15

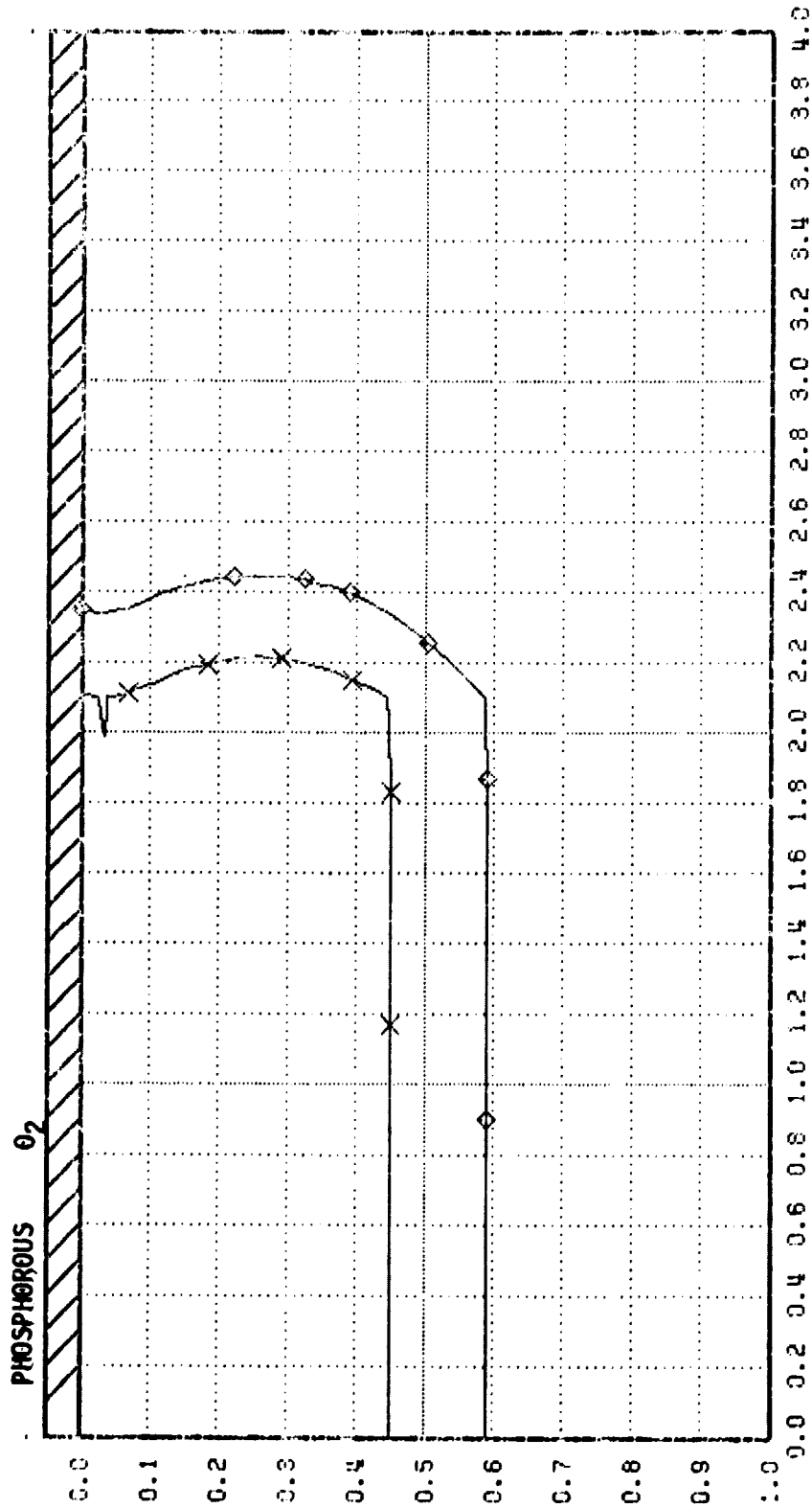


ORIGINAL PAGE IS
OF POOR QUALITY

B 22

X² = 1.0E20
TEMPERATURE = 0.0000
TIME STEP = 1000.
TIME = 60
TIME = 4320.00

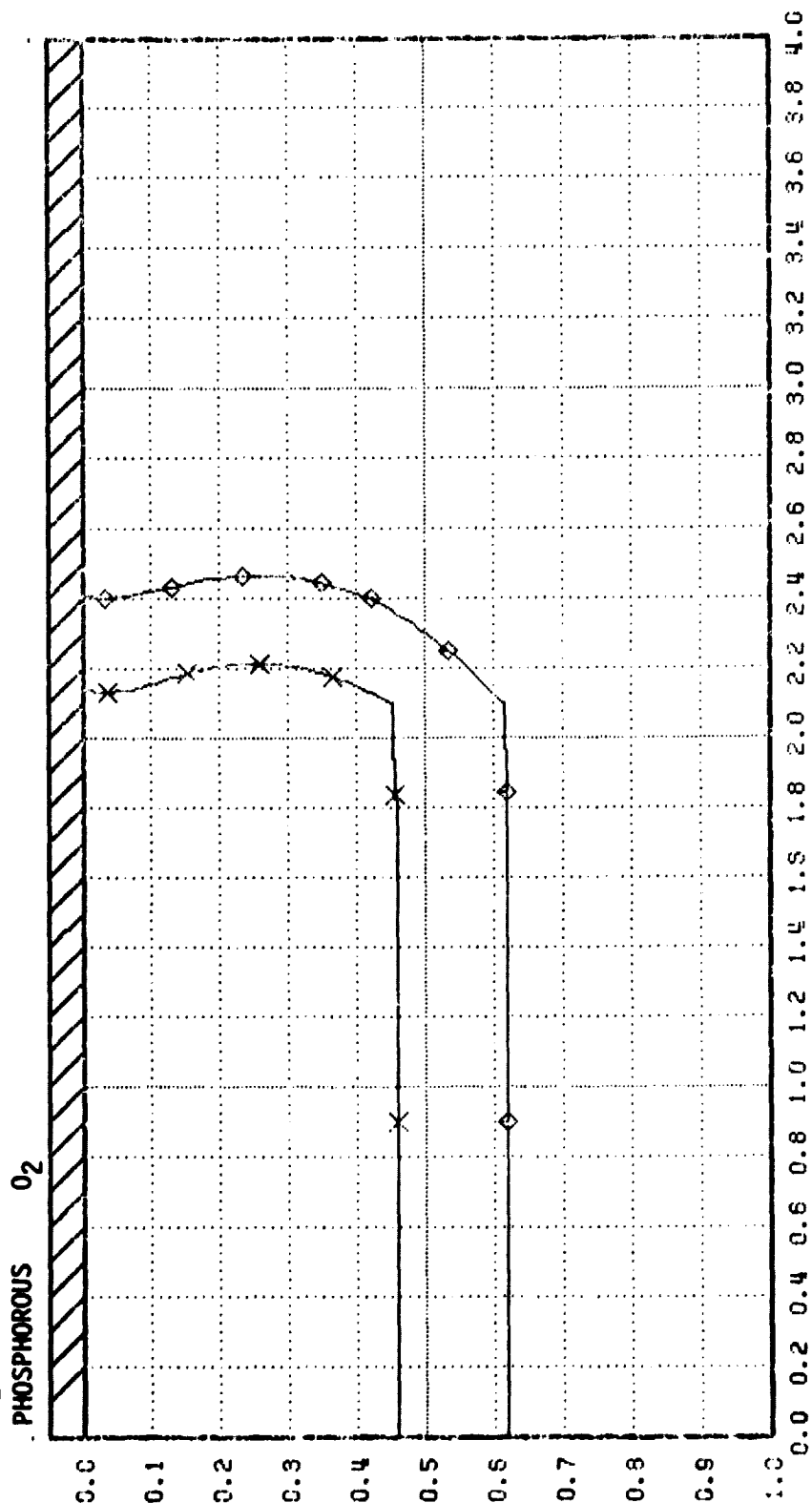
□ - 1.0E20
○ - 1.0E19
△ - 1.0E18
+ - 1.0E17
x - 1.0E16
◇ - 1.0E15



λ^2
 TEMPERATURE
 TIME STEP
 TIME

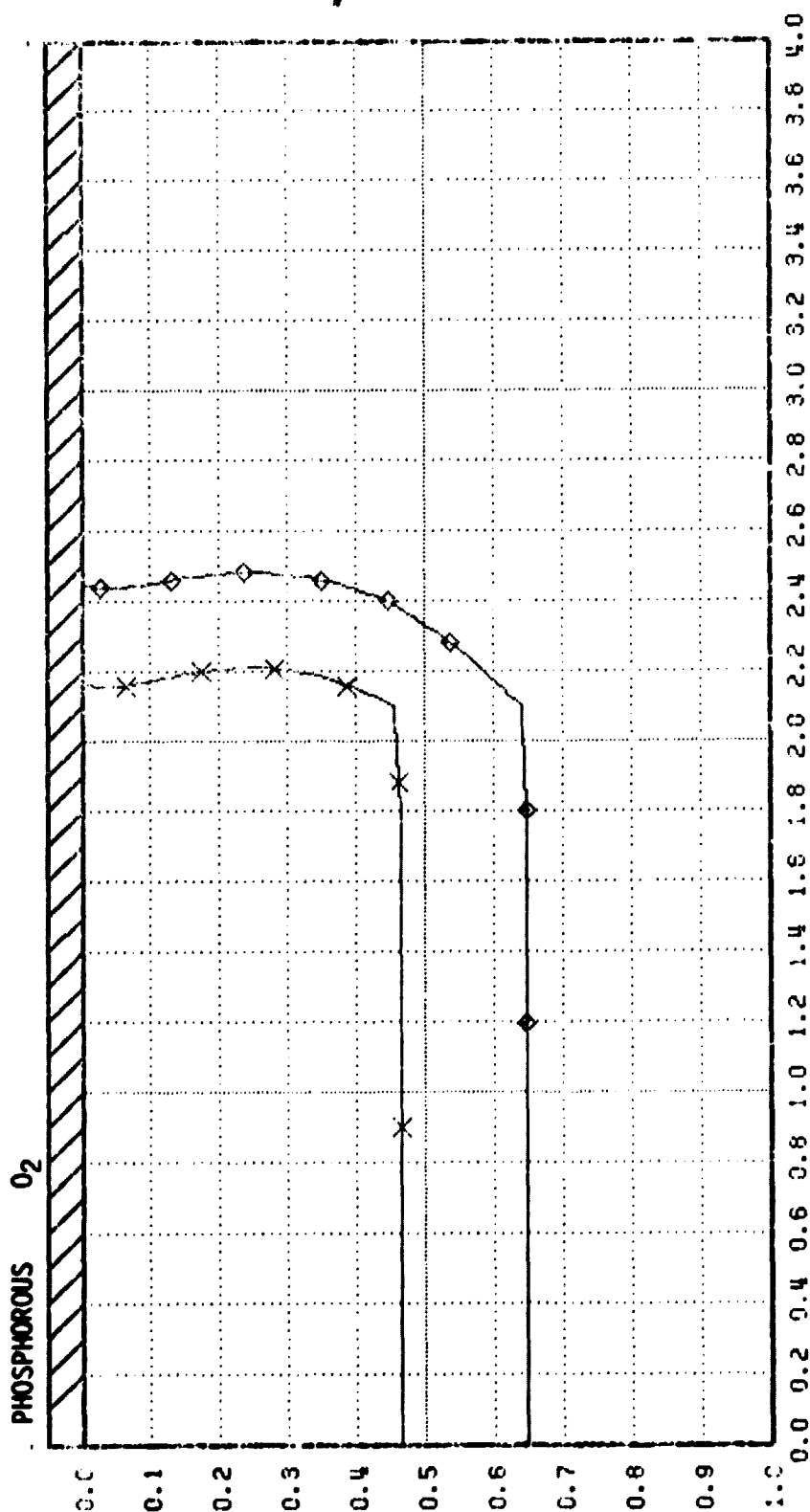
= 0.0000
 = 1000.
 = 80
 = 5760.00

E 0 4 + X \diamond
 - 1.0E20
 - 1.0E19
 - 1.0E18
 - 1.0E17
 - 1.0E16
 - 1.0E15



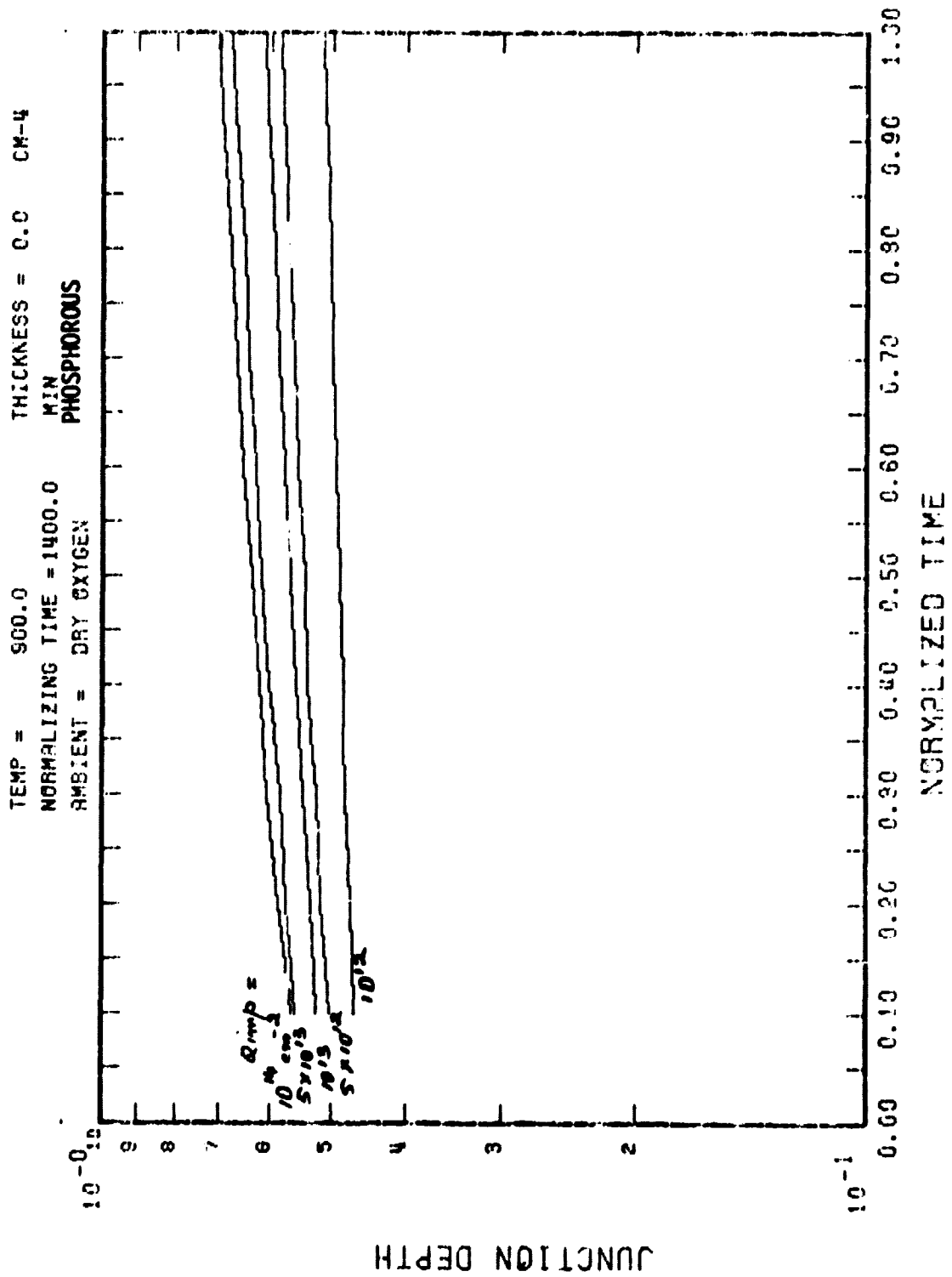
X² = 0.0000
 TEMPERATURE = 1000.
 TIME STEP = 100
 TIME = 7200.00

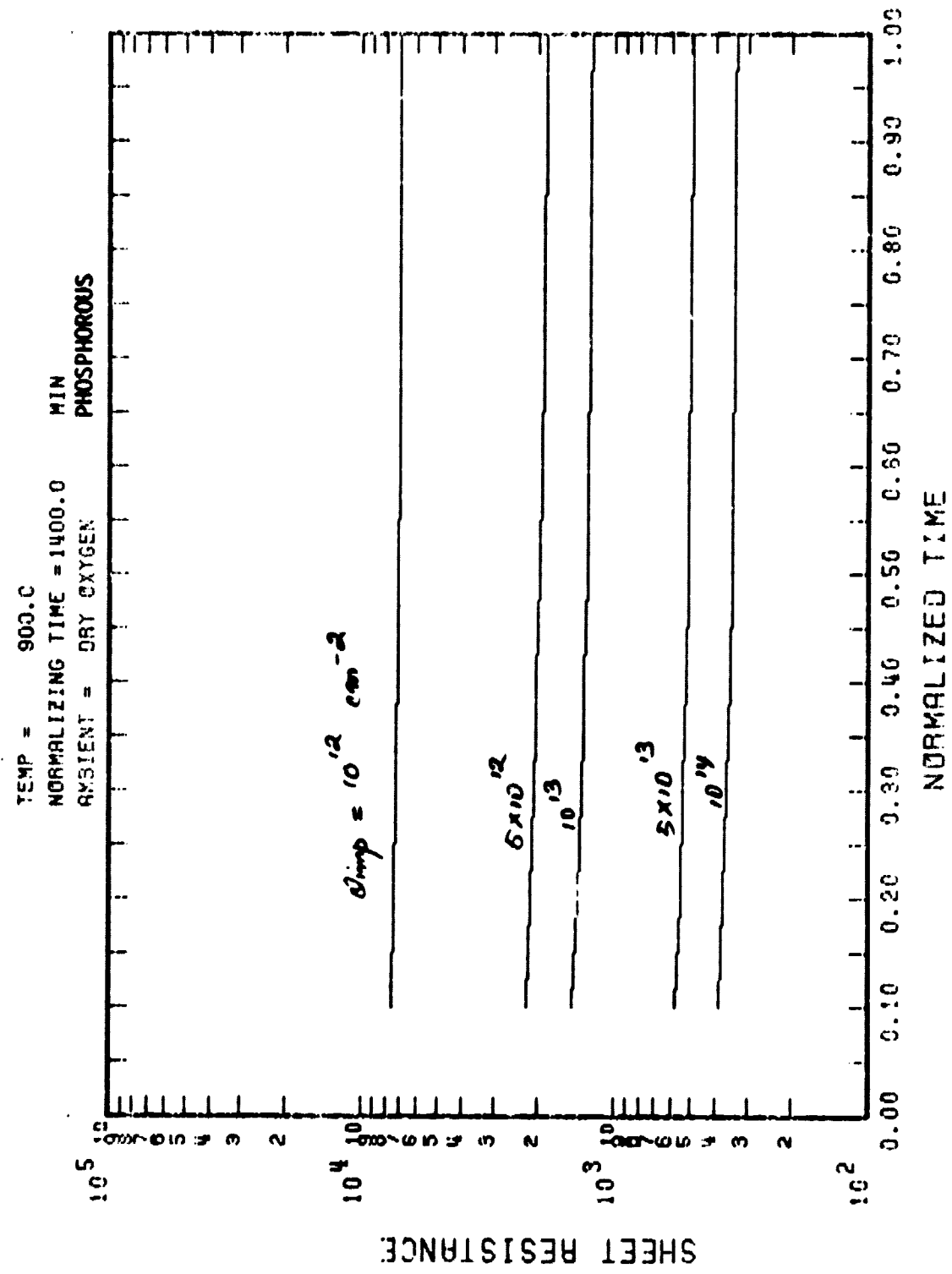
□ - 1.0E20
 ○ - 1.0E19
 △ - 1.0E18
 + - 1.0E17
 x - 1.0E16
 ◇ - 1.0E15



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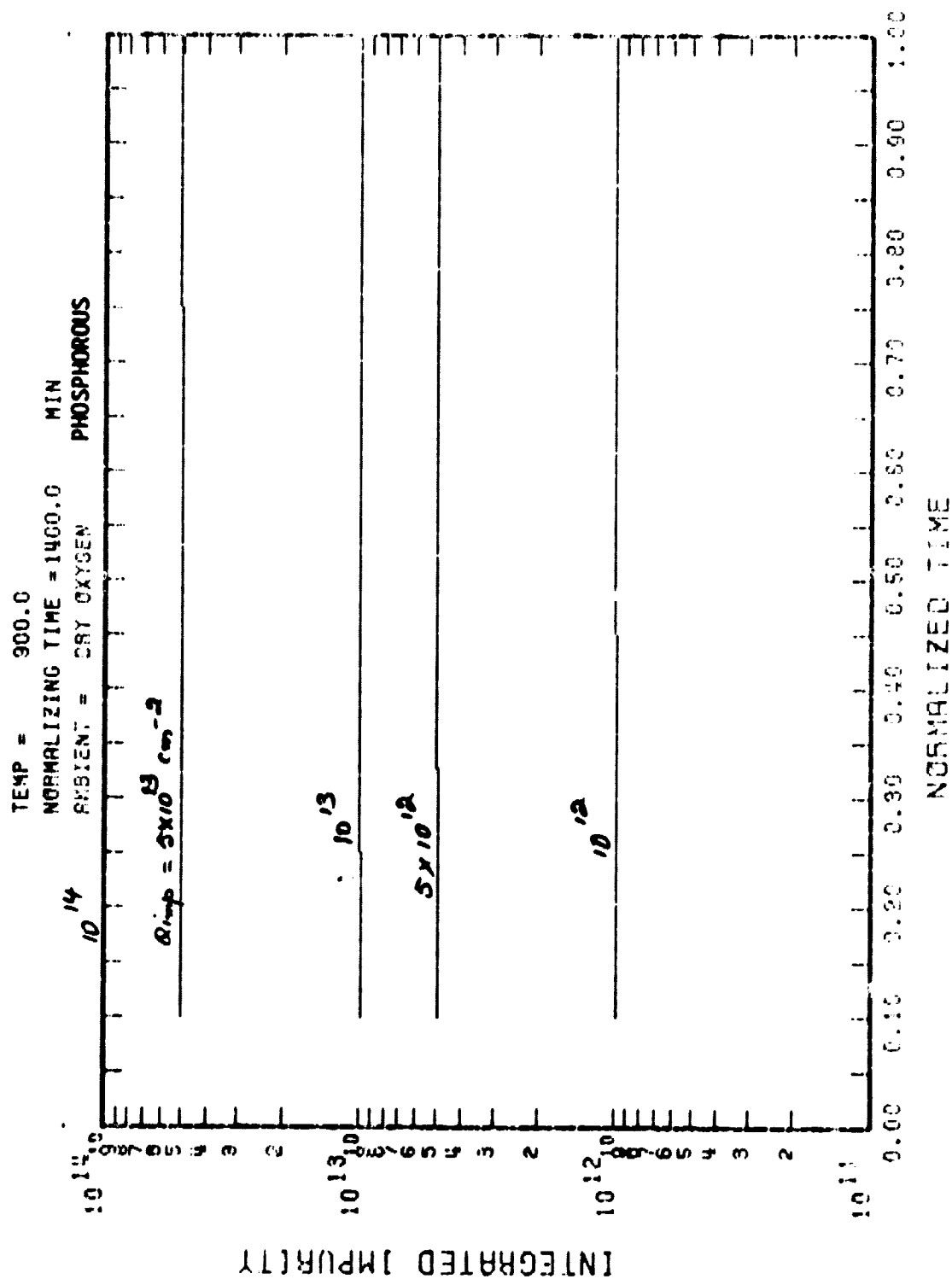
B 25

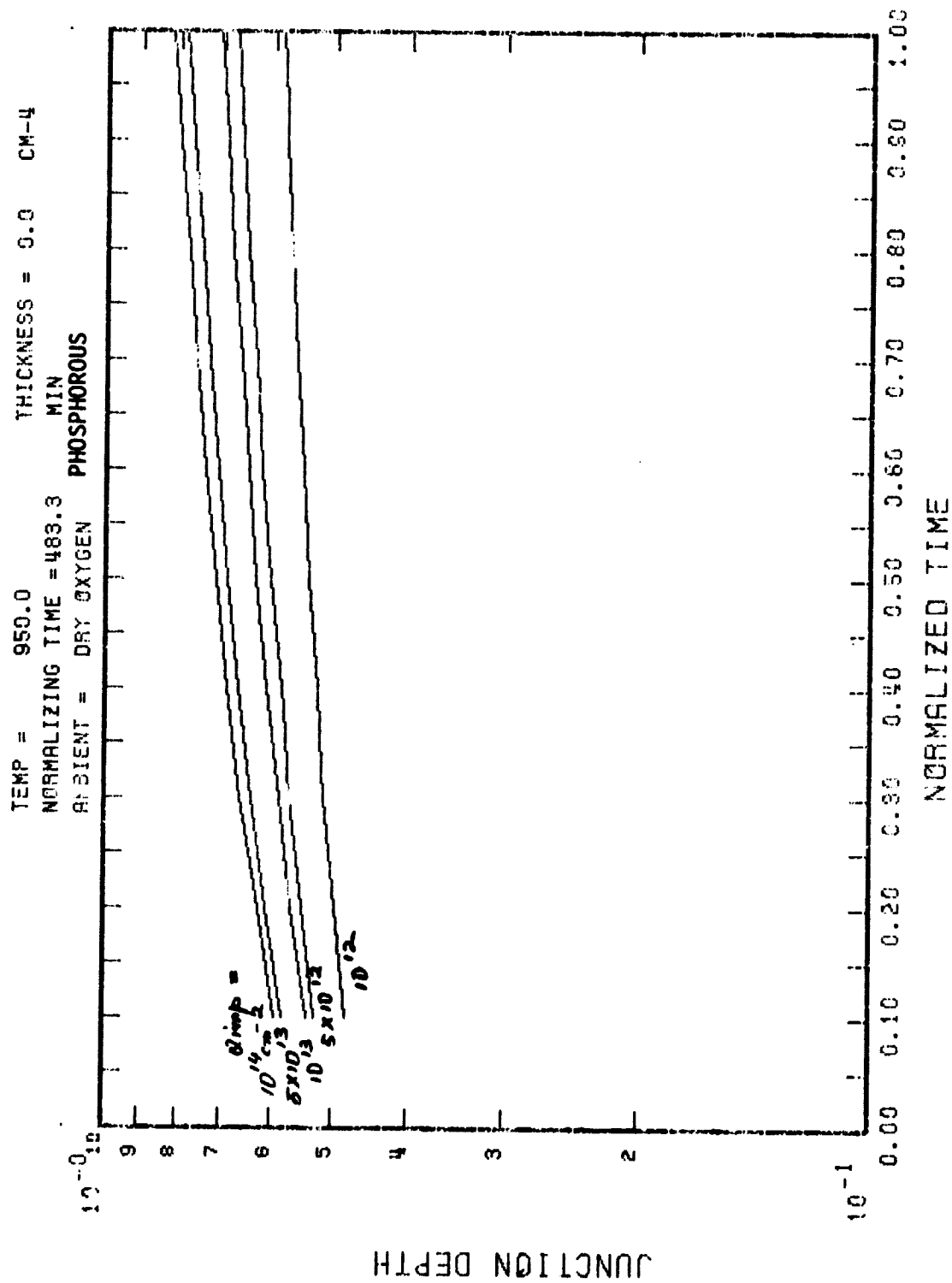




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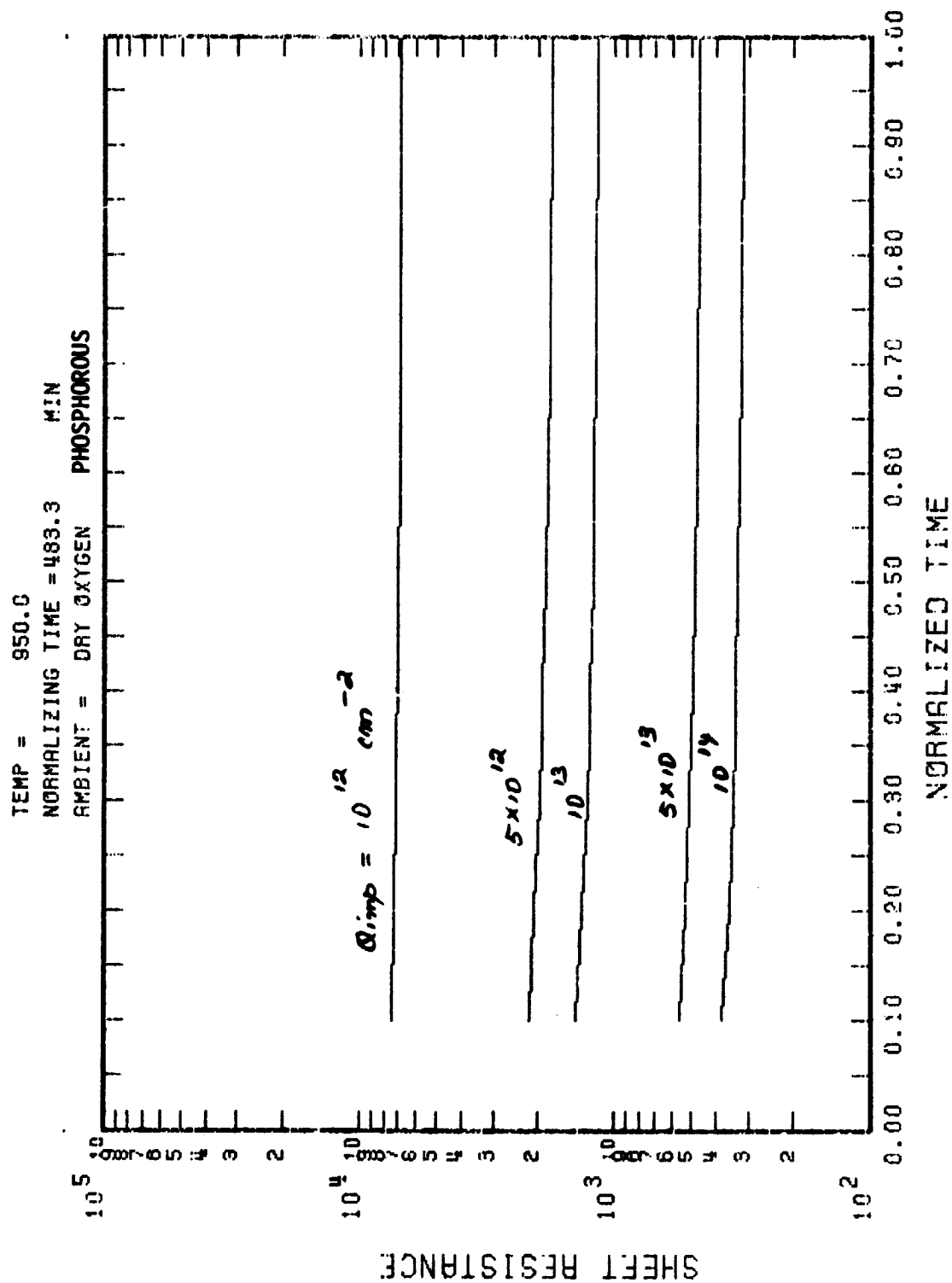
B 27



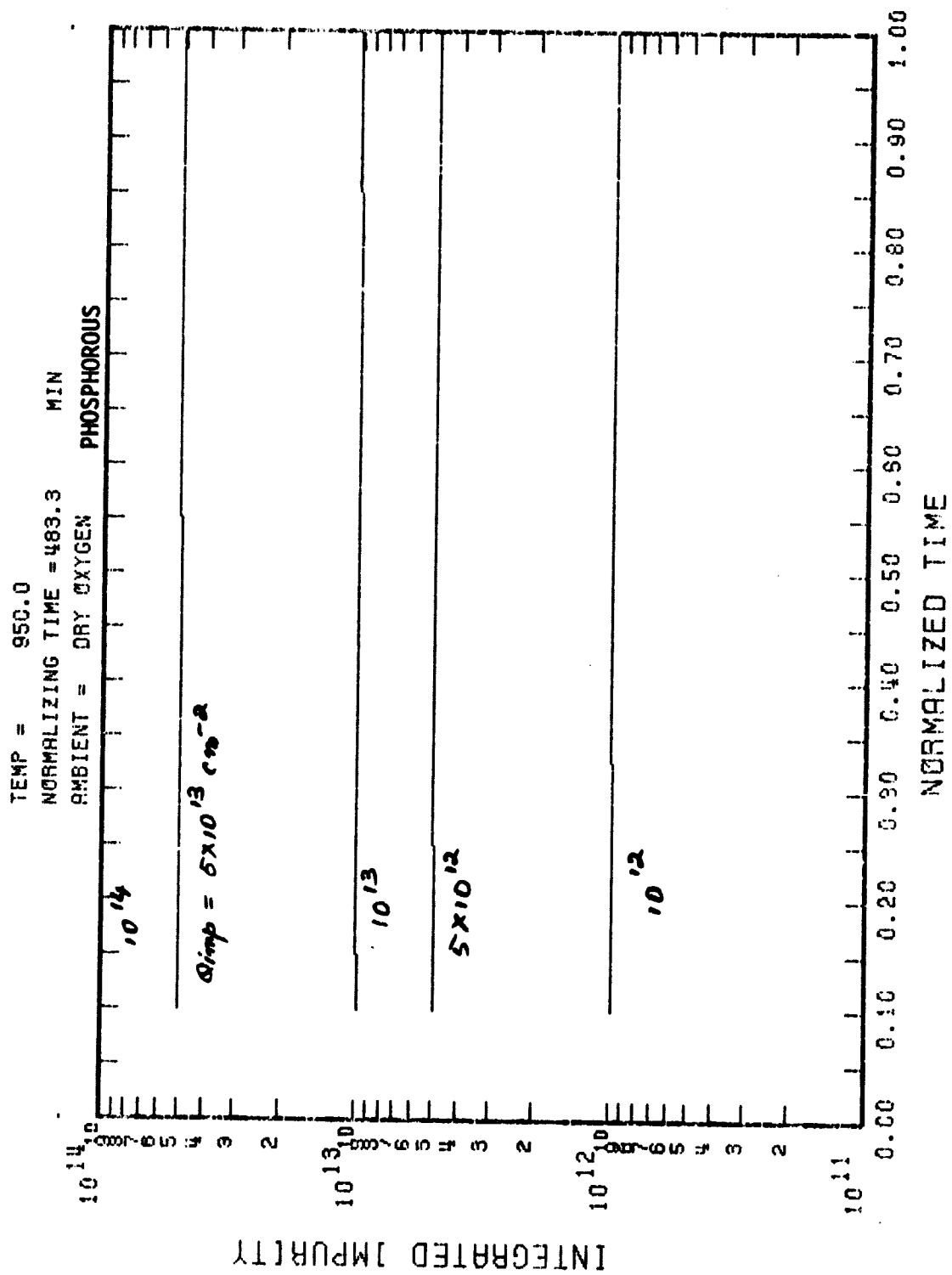


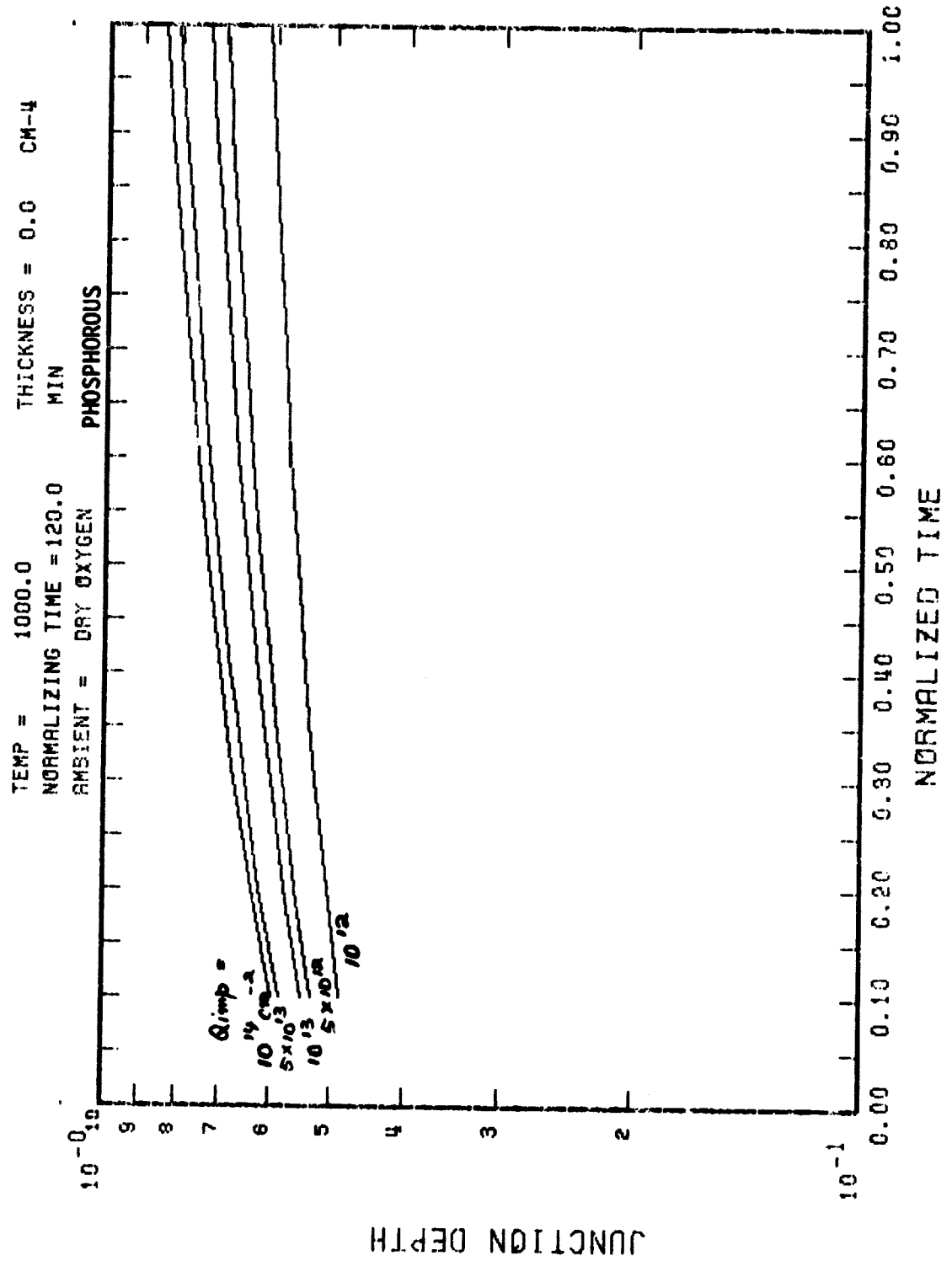
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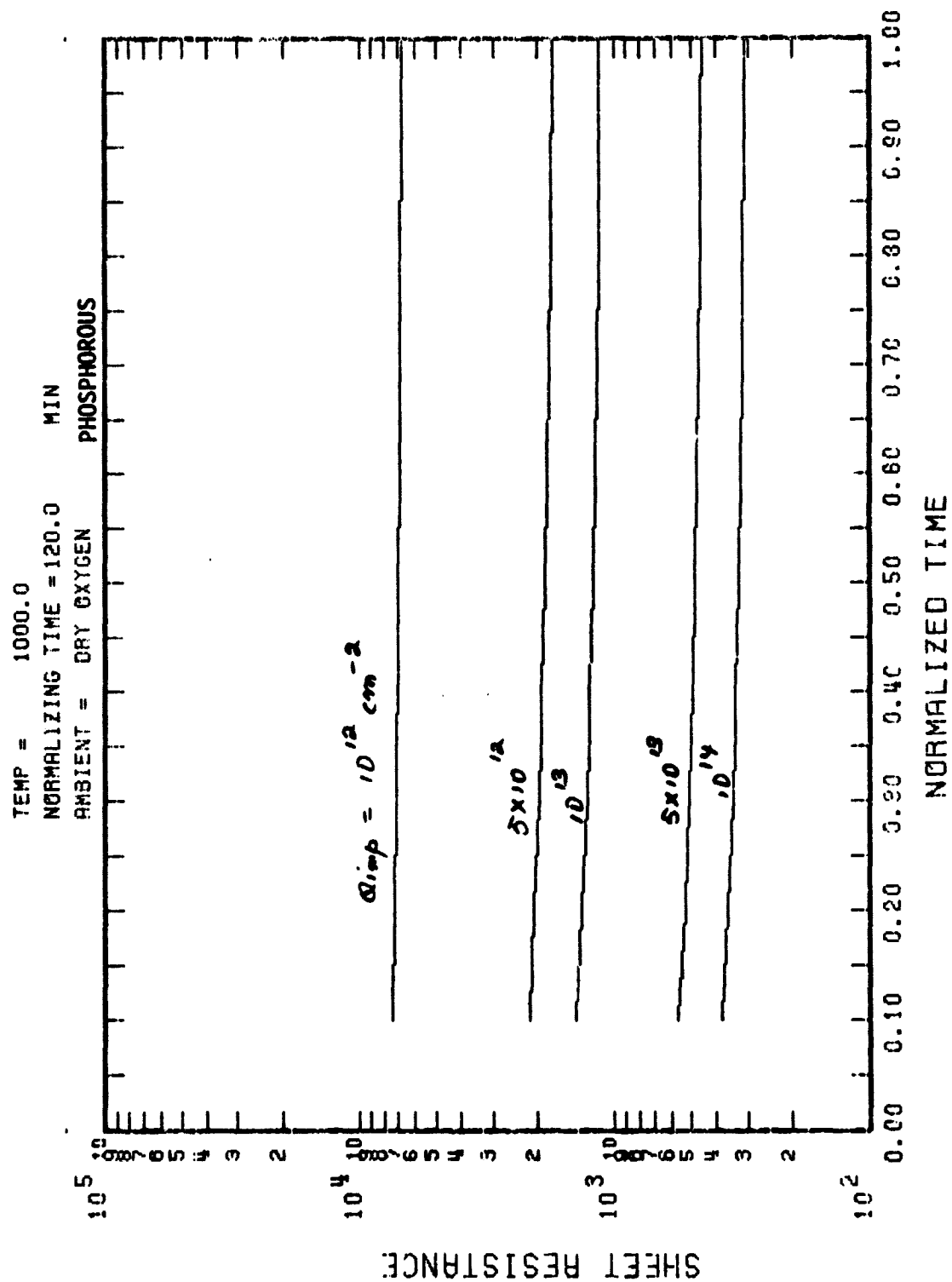
B 29



B 30

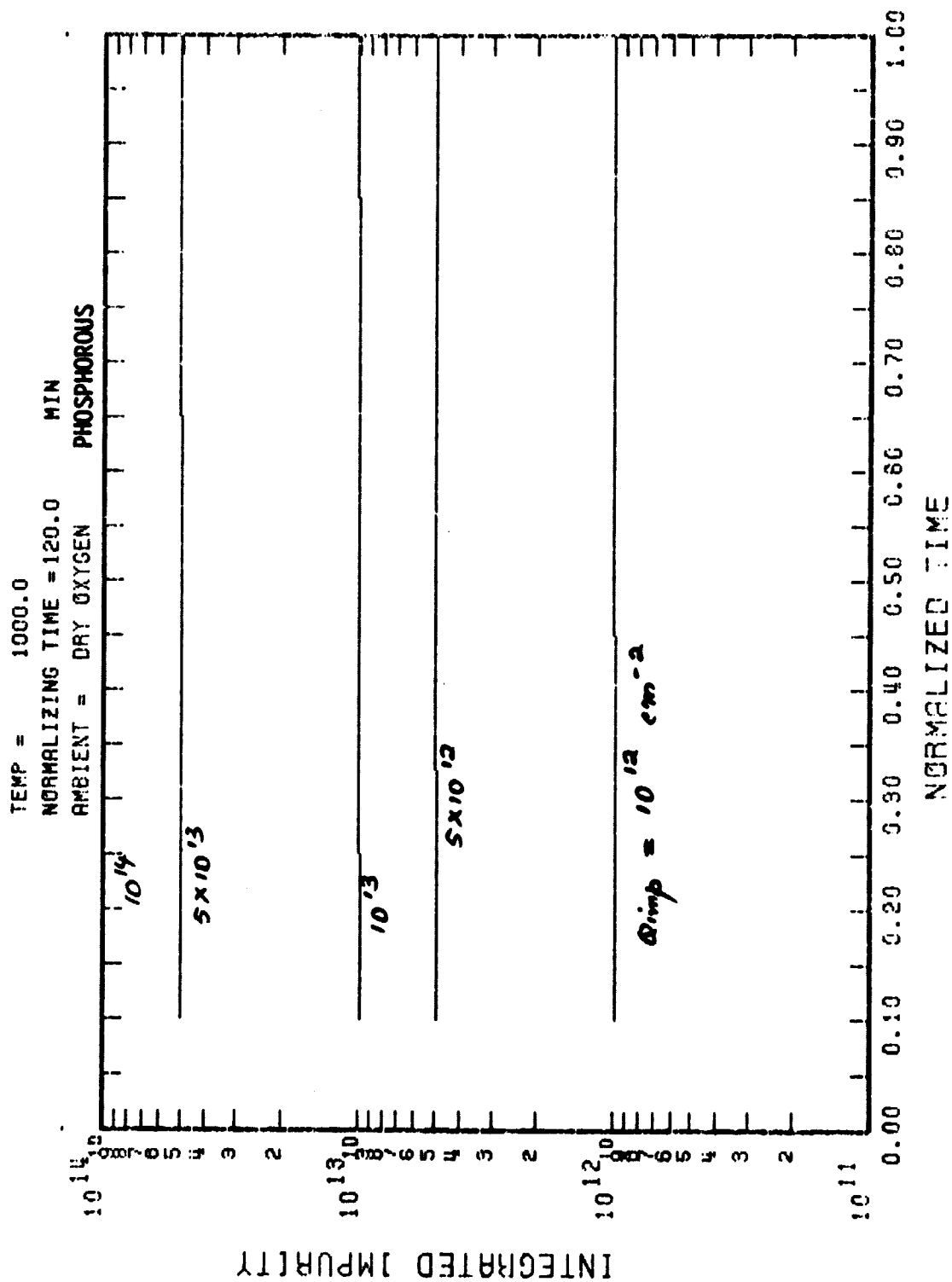


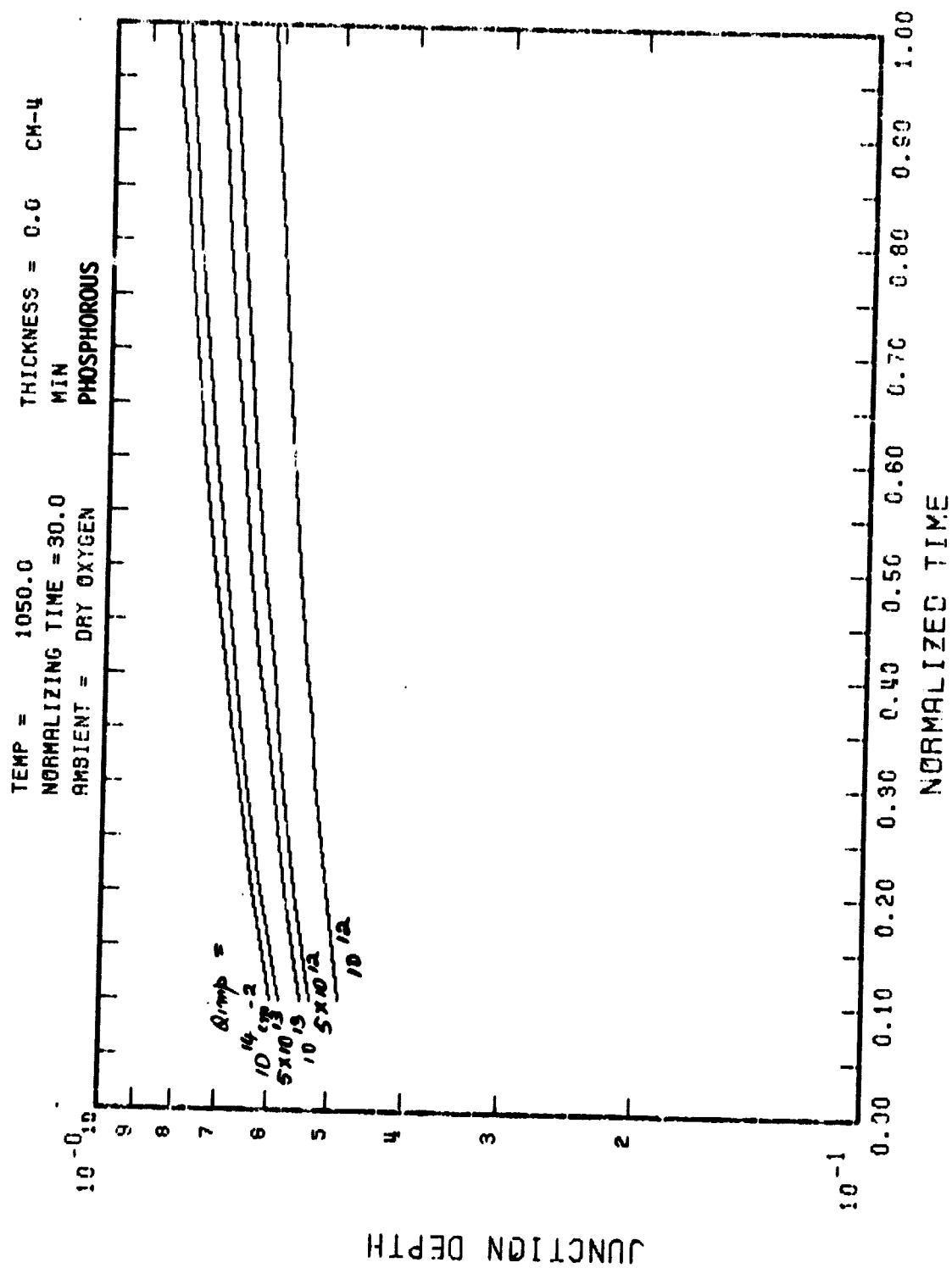


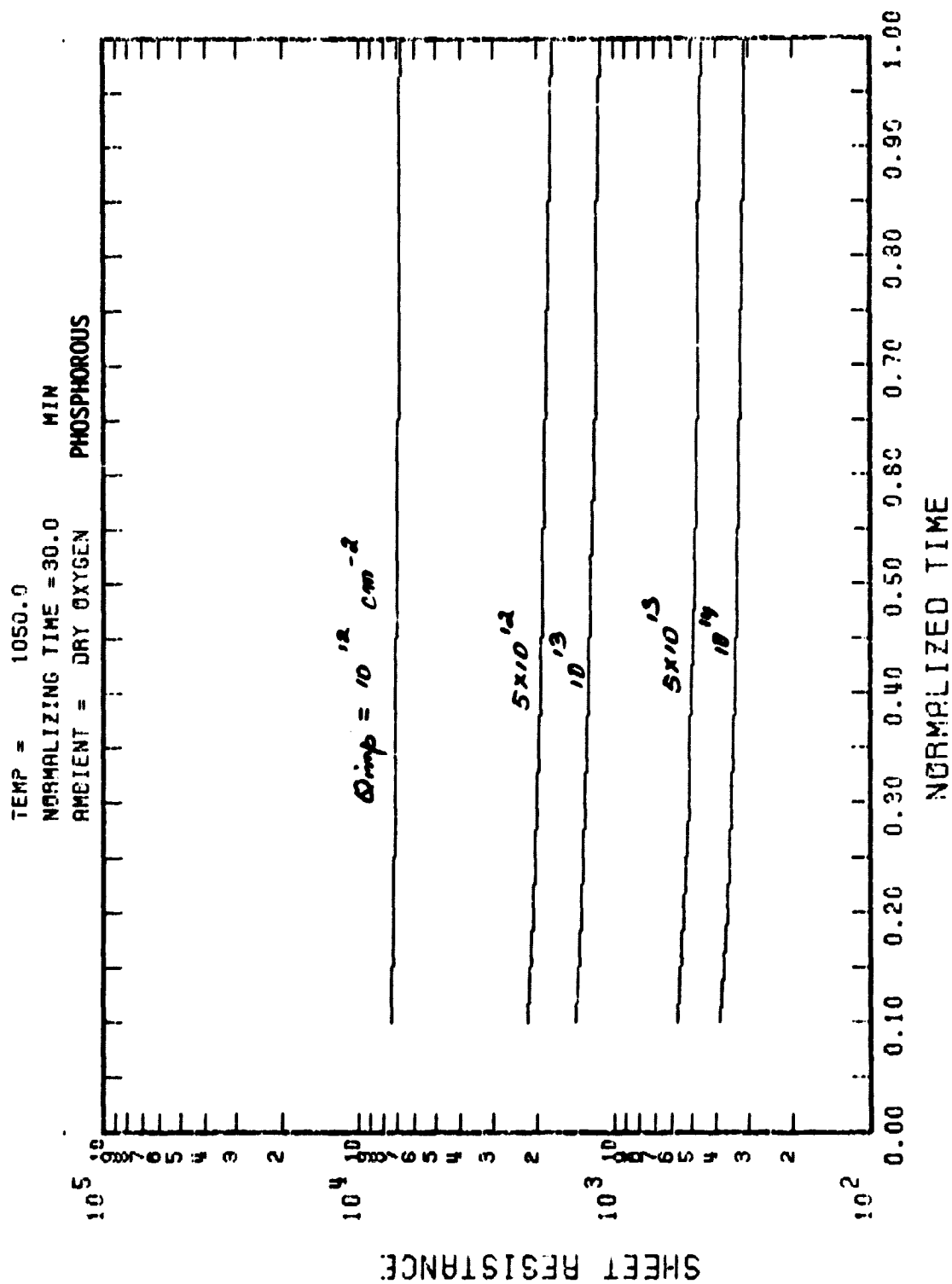


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B 33

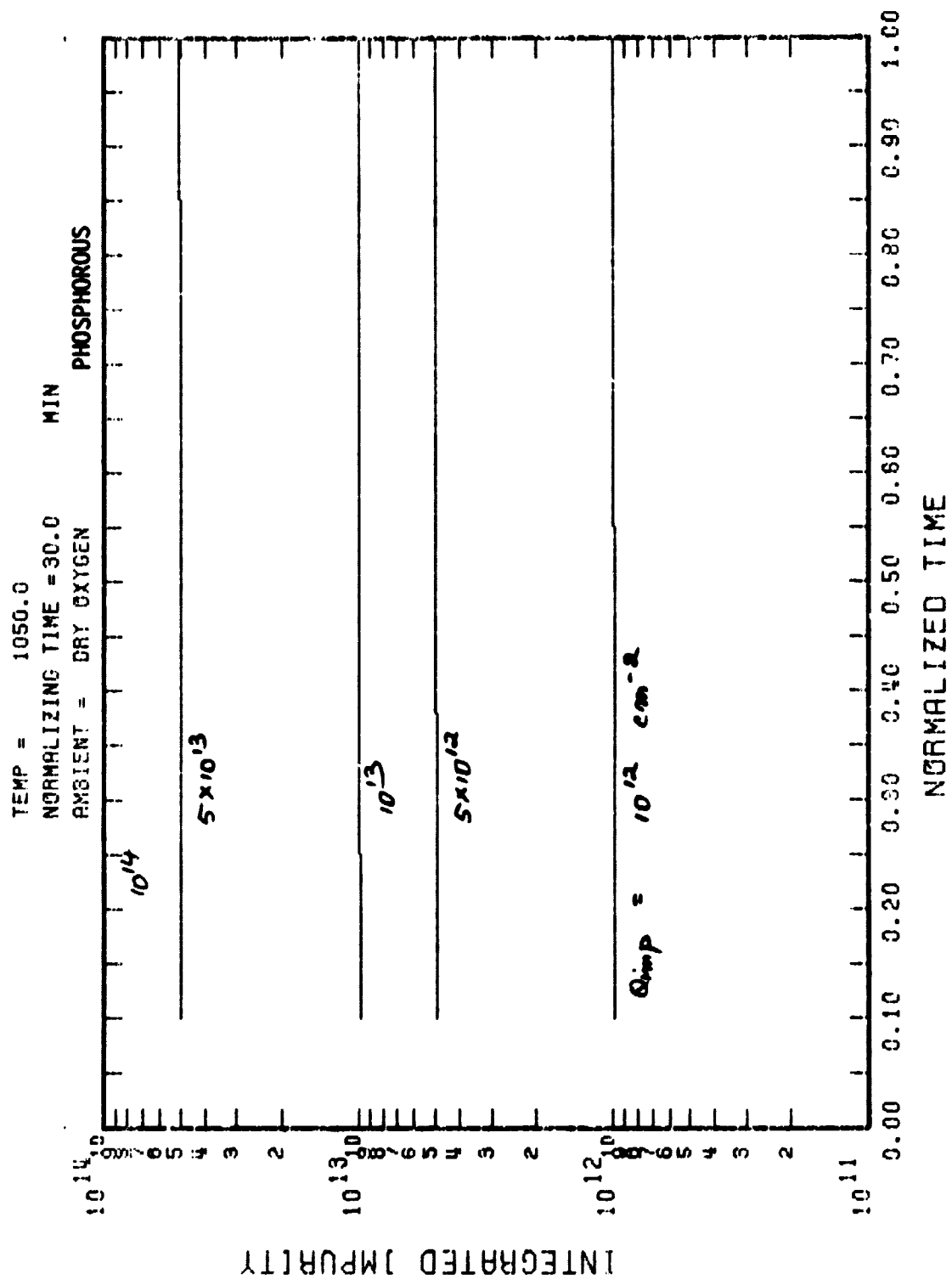






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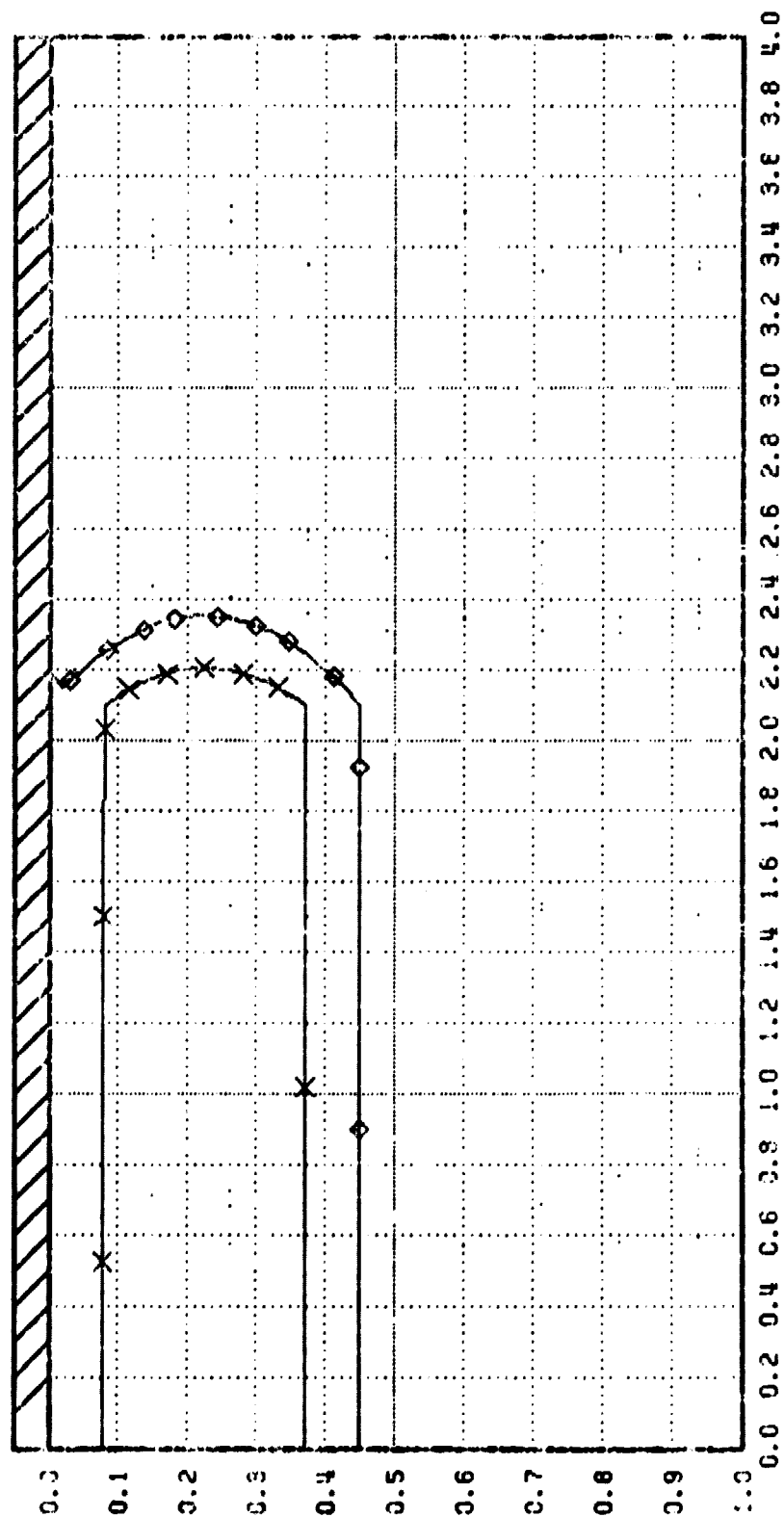
B 36



| | | | | |
|-------------|----------|---|---|--------|
| χ^2 | = 0.0000 | E | - | 1.0E20 |
| TEMPERATURE | = 1000. | O | - | 1.0E19 |
| TIME STEP | = 0.0000 | A | - | 1.0E18 |
| TIME | = 0.0000 | + | - | 1.0E17 |
| | | X | - | 1.0E16 |
| | | D | - | 1.0E15 |

λ^2 TEMPERATURE = 0.0000
 TIME STEP = 1000.
 TIME = 20
 PHOSPHOROUS STEAM = 720.00

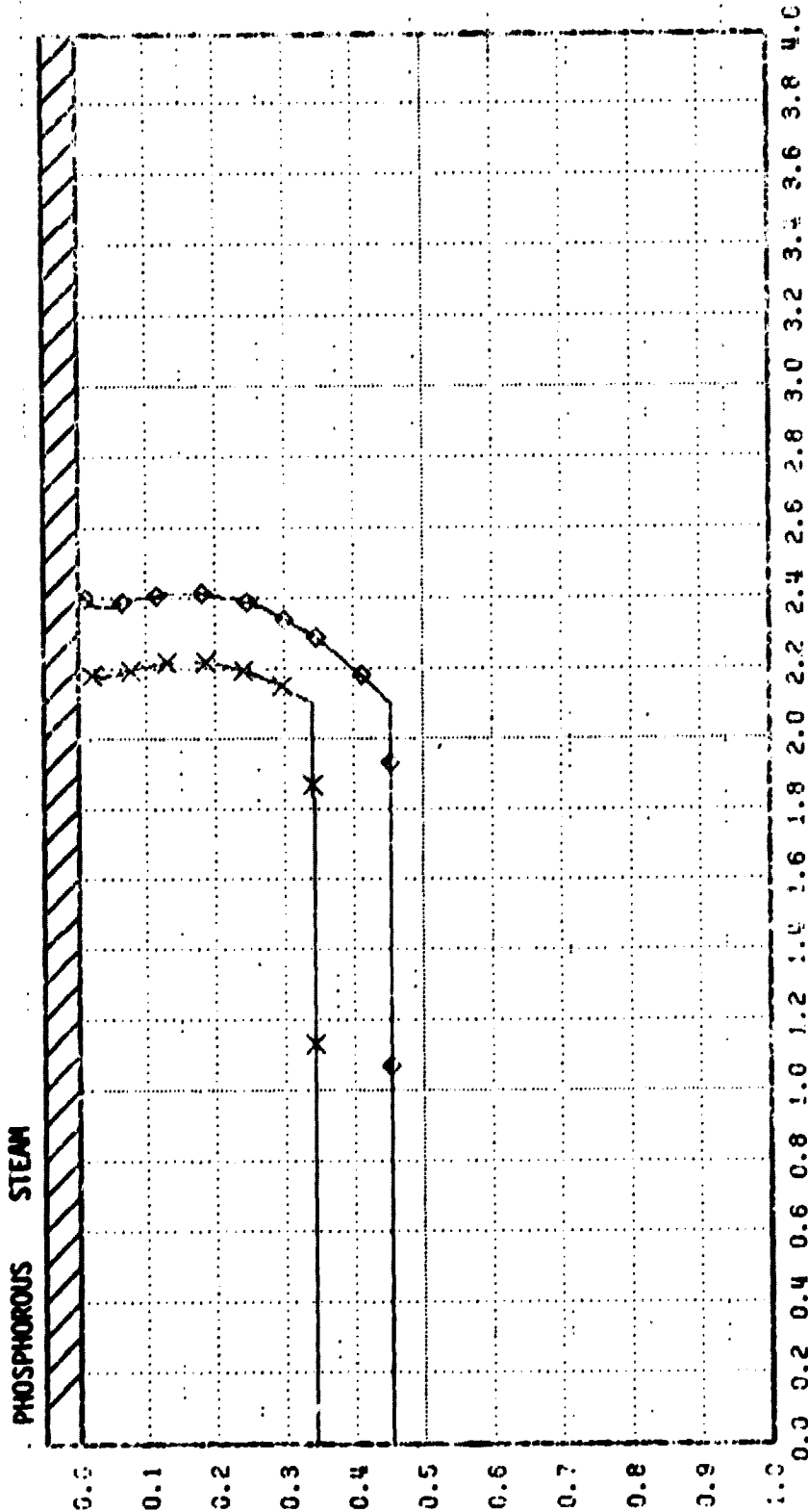
E 0 - 1.0E20
 0 - 1.0E19
 1 - 1.0E18
 2 - 1.0E17
 3 - 1.0E16
 4 - 1.0E15



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B 39

χ^2
 TEMPERATURE = 1000.
 TIME STEP = 50
 TIME = 2160.00
 E = 1.0E20
 = 1.0E18
 = 1.0E18
 = 1.0E17
 = 1.0E18
 = 1.0E15



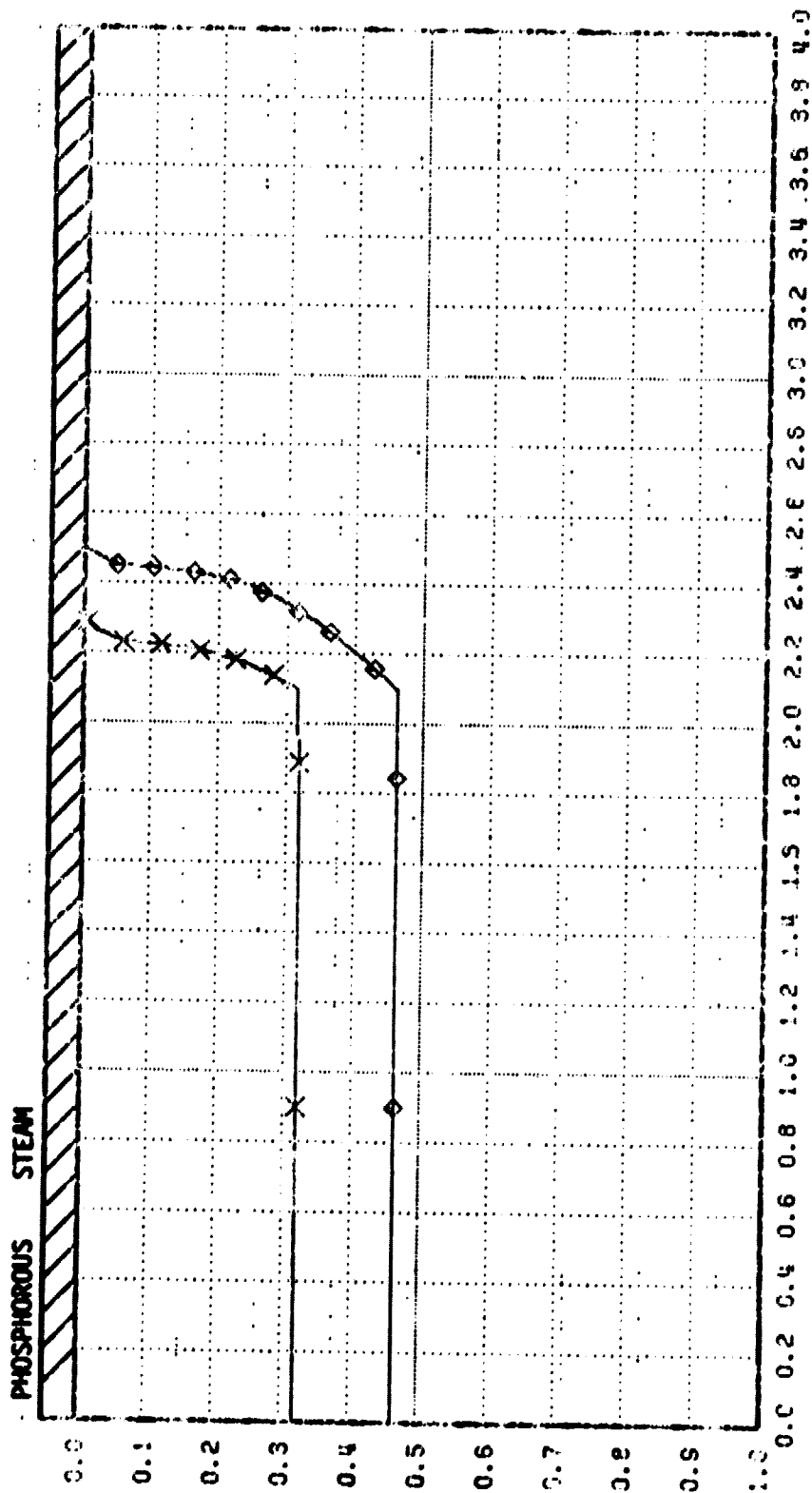
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B 40

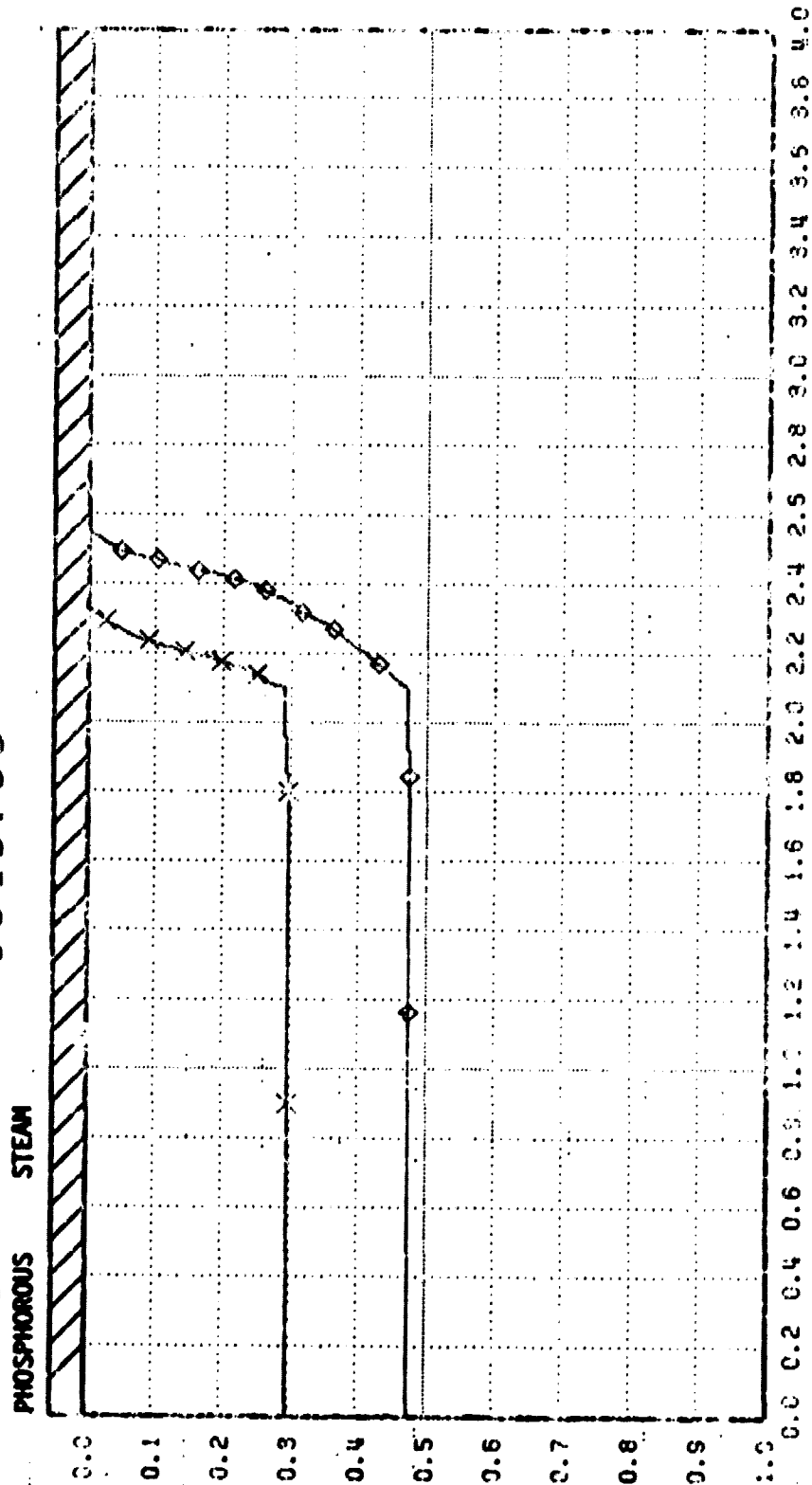
λ^2
 TEMPERATURE
 TIME STEP
 TIME

= 0.0000
 = 1000.
 = 100
 = 3600.00

E - 1.0E20
 O - 1.0E16
 A - 1.0E18
 + - 1.0E17
 X - 1.0E15
 O - 1.0E15

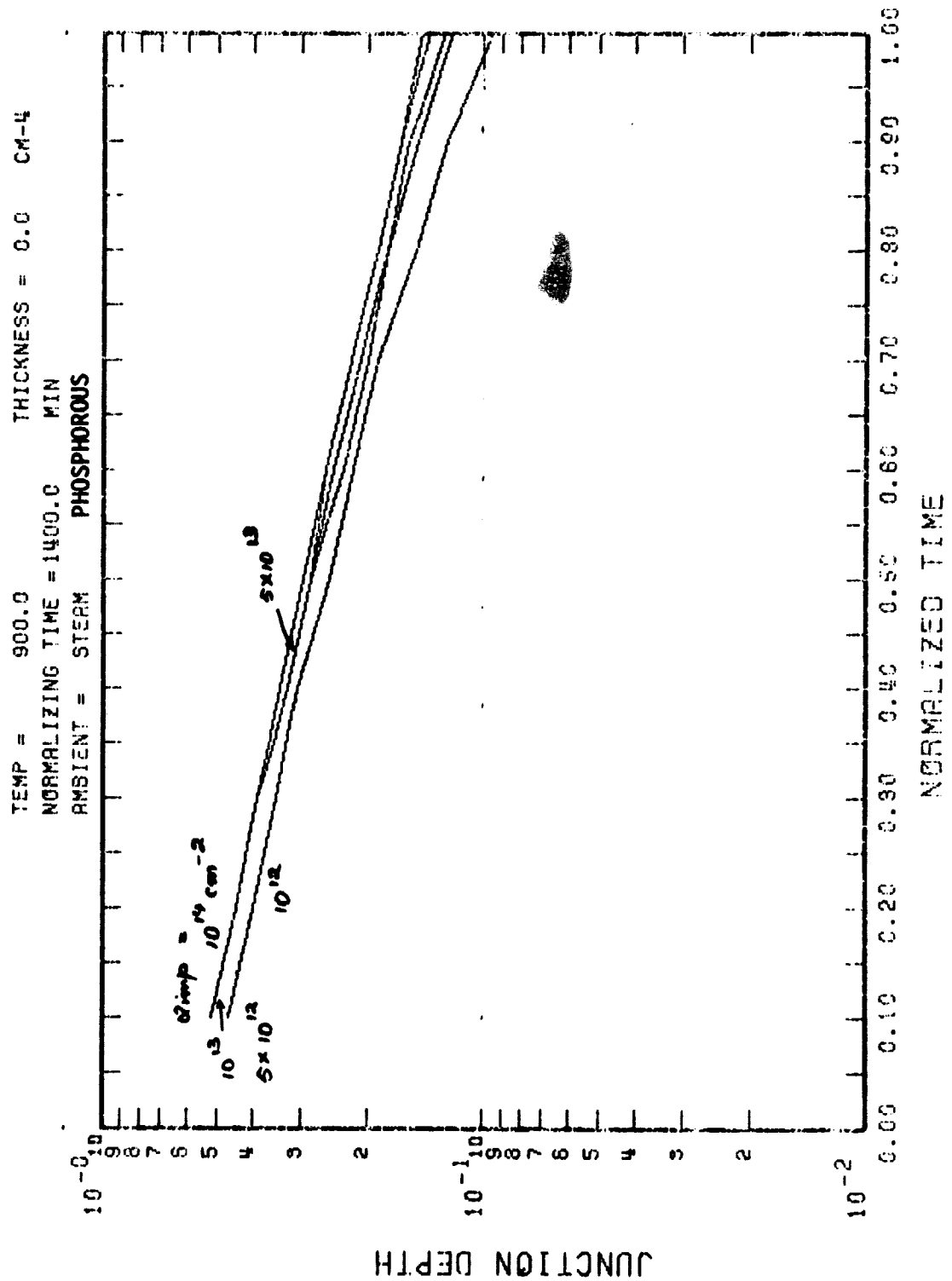


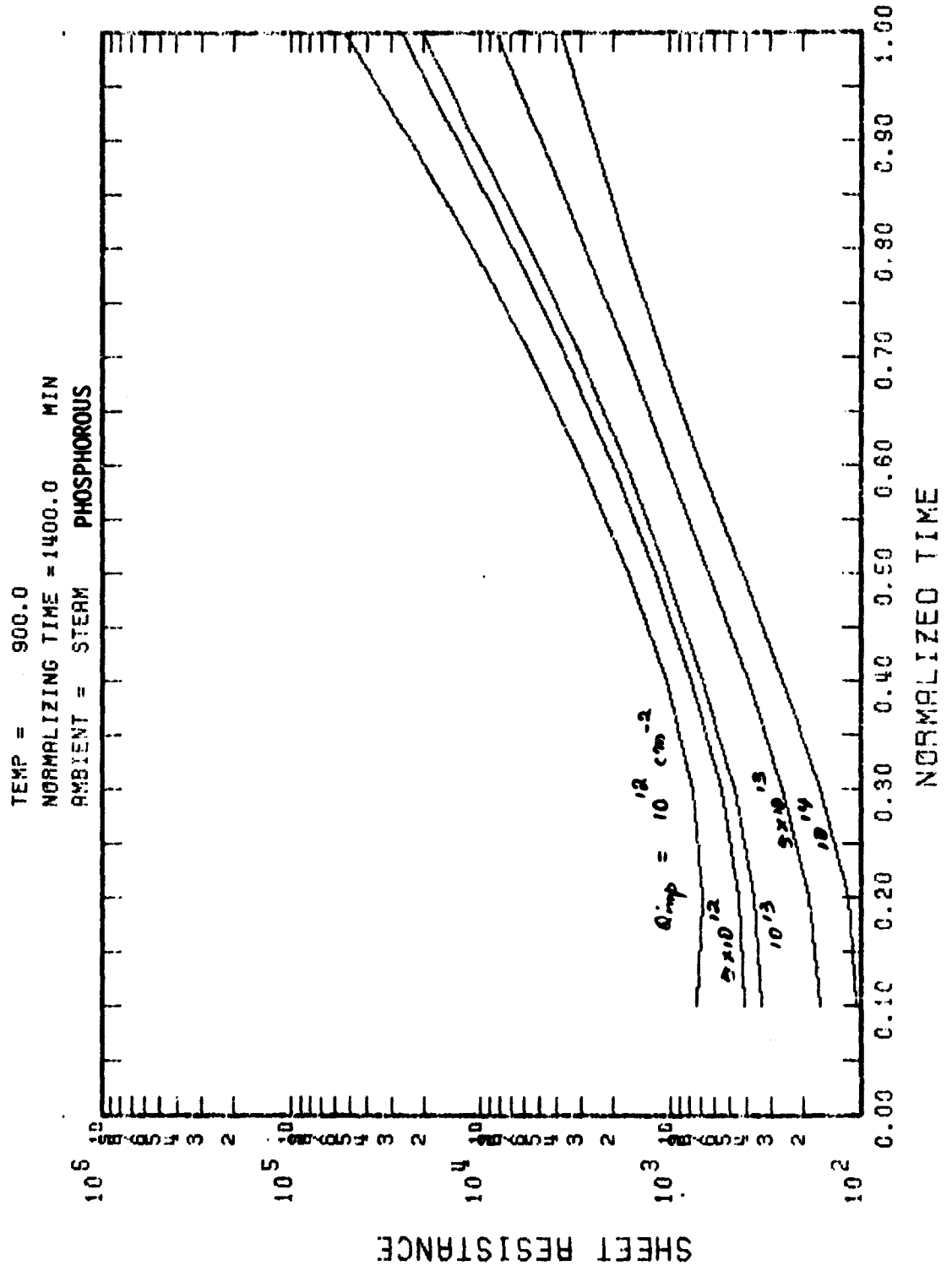
λ^2
 TEMPERATURE
 TIME STEP
 TIME
 = 0.0000
 = 1000.
 = 140
 = 5040.00
 E 0 4 + X \diamond
 - 1.0529
 - 1.0515
 - 1.0519
 - 1.0517
 - 1.0516
 - 1.0515



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B 42

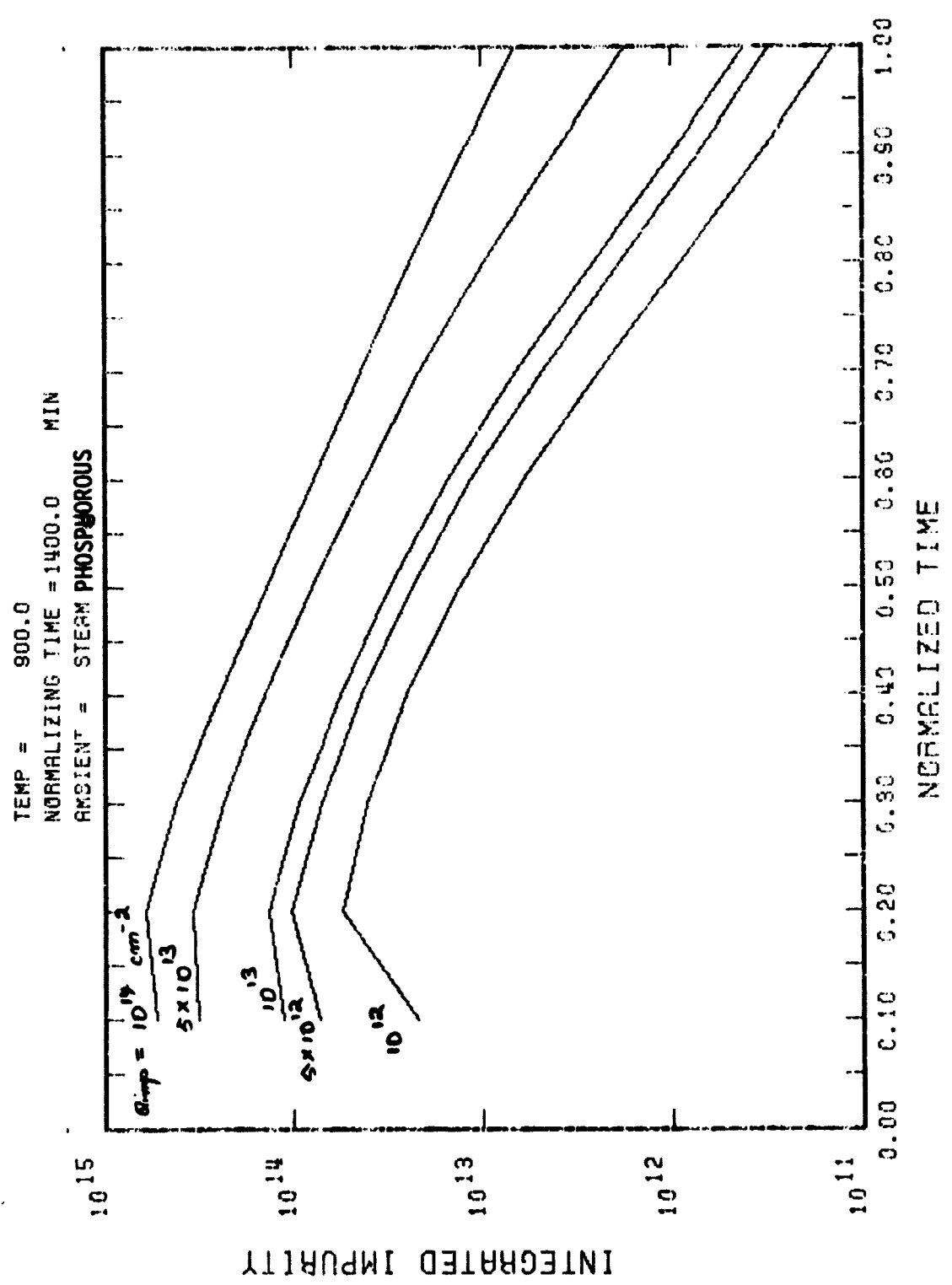




47

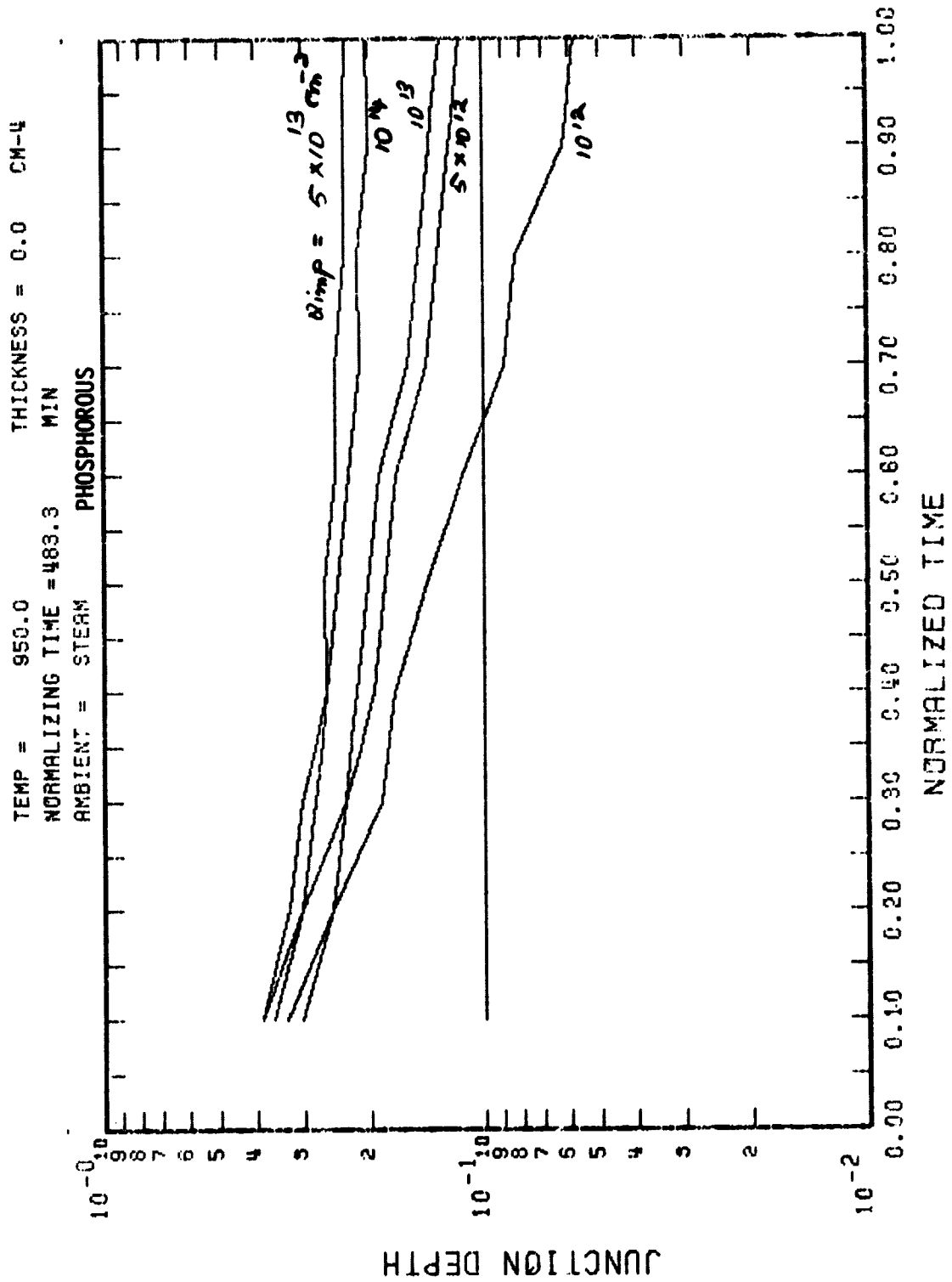
10015
QUALITY

B 44

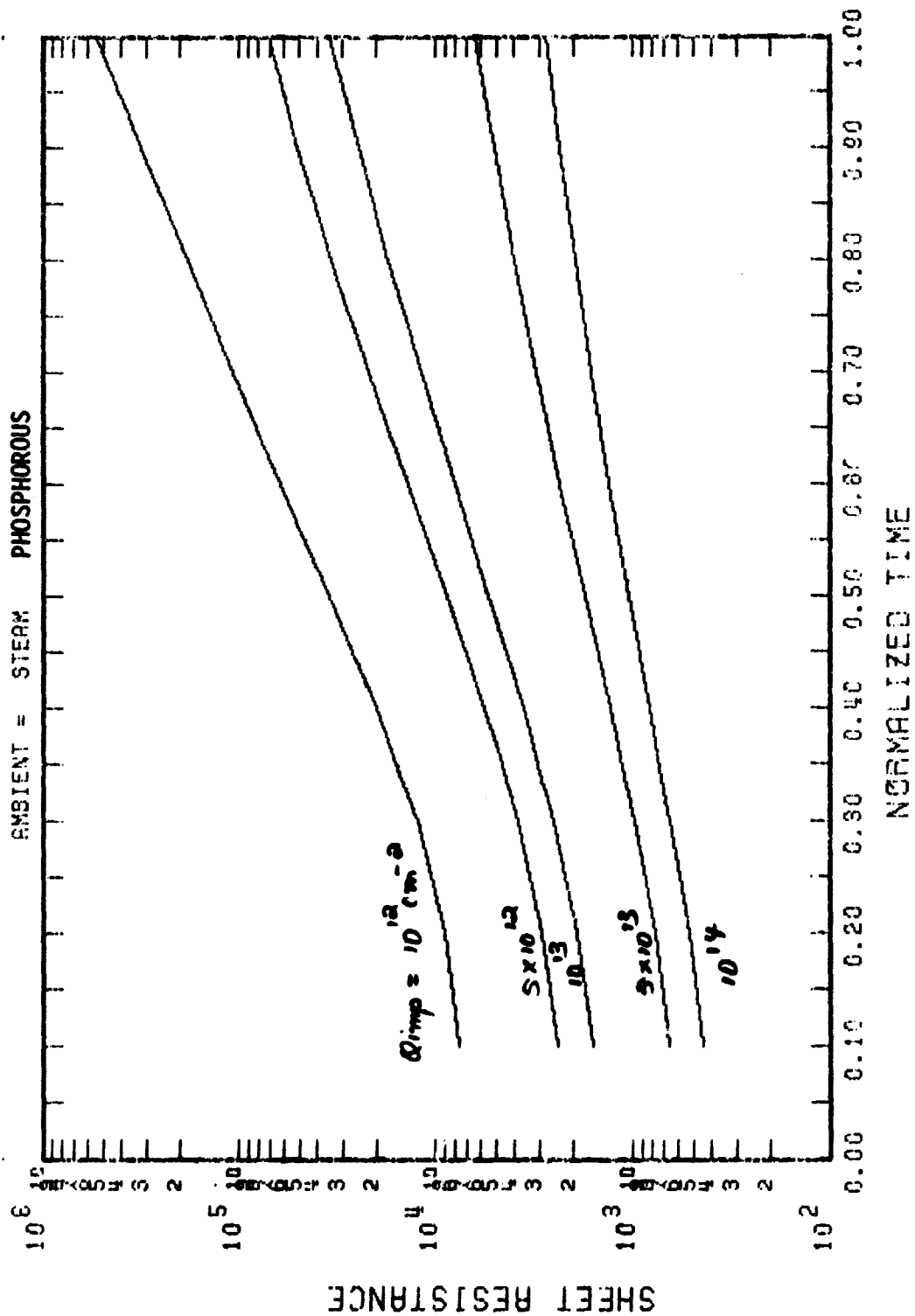


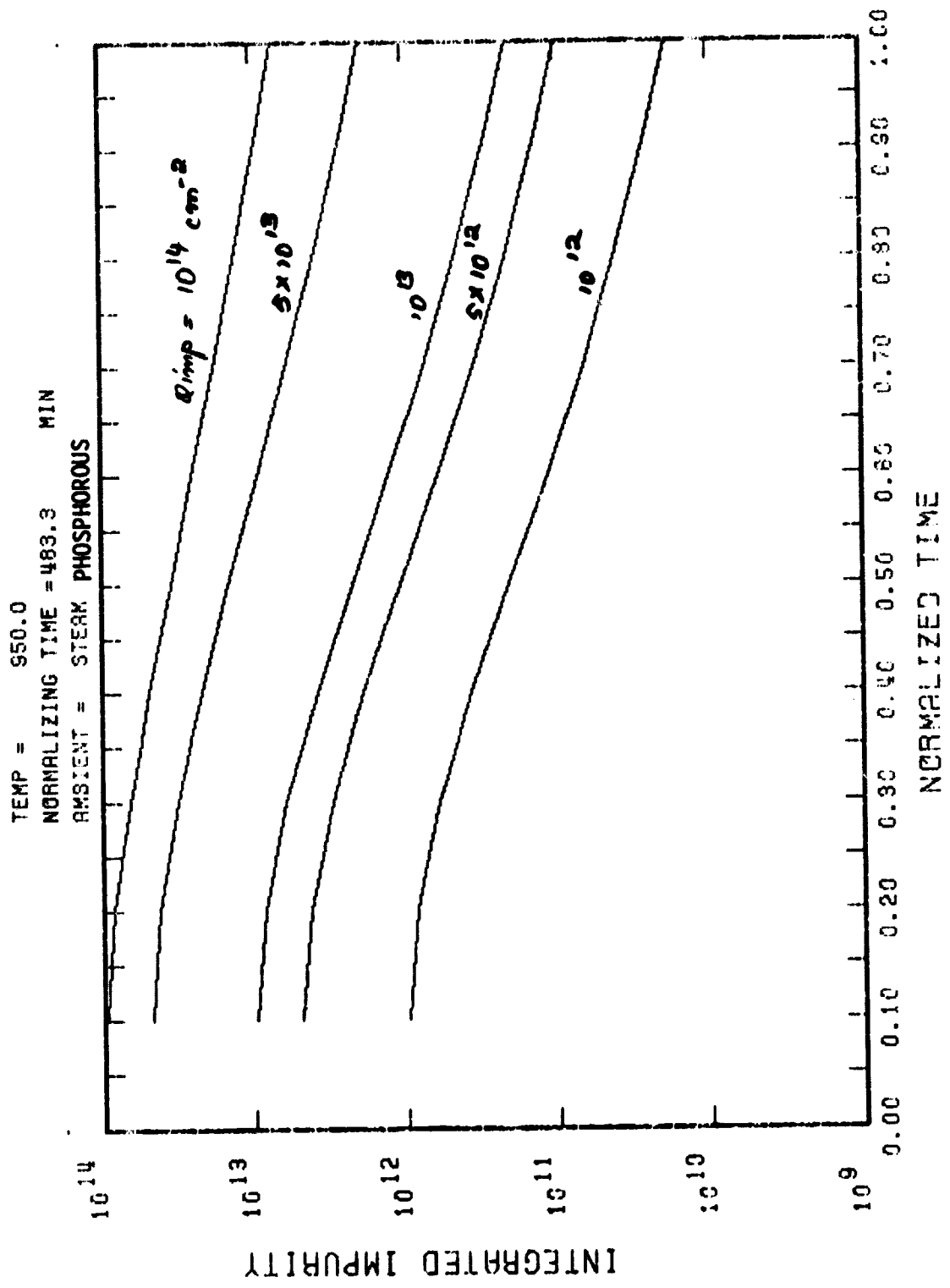
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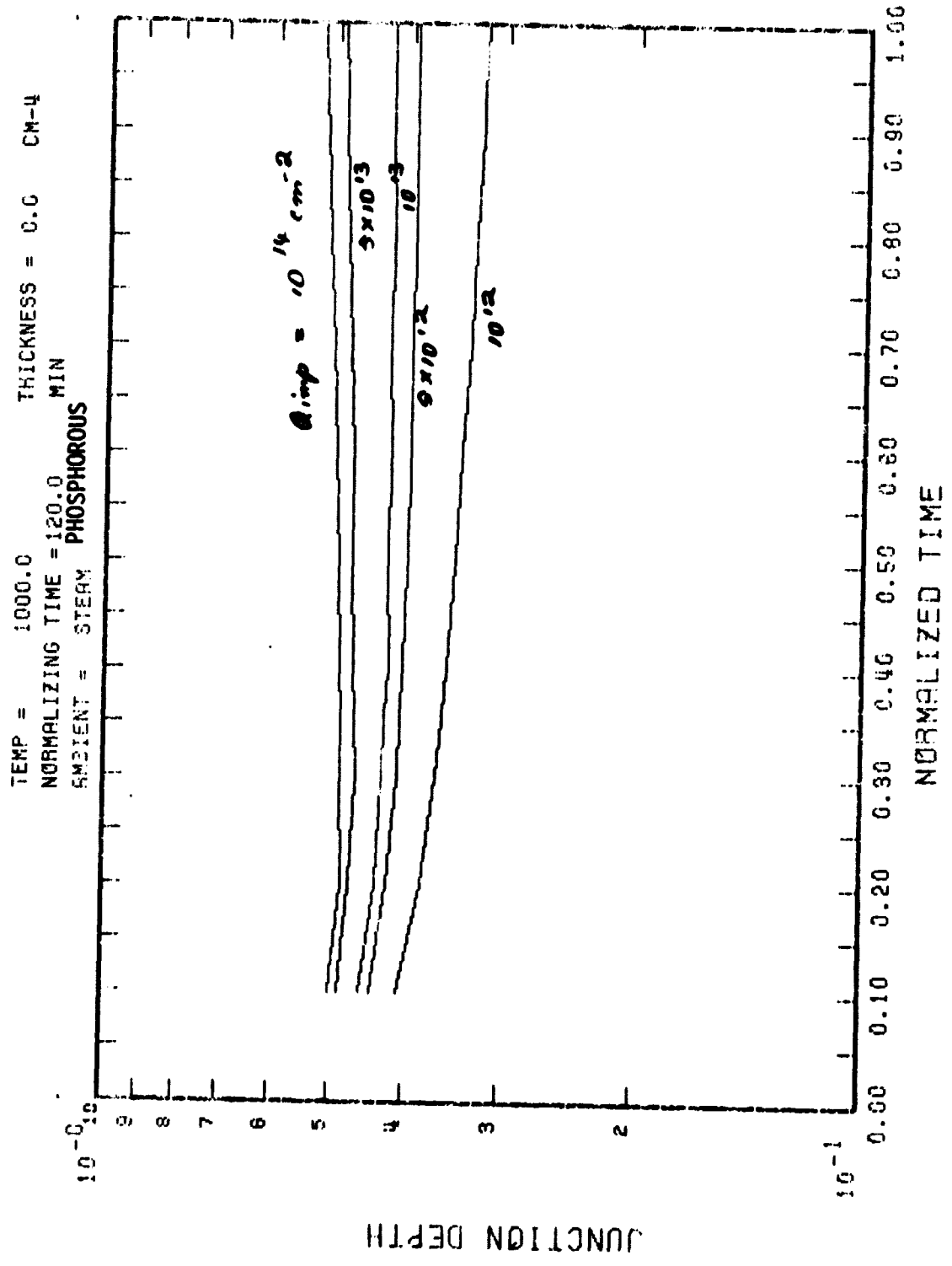
B 45

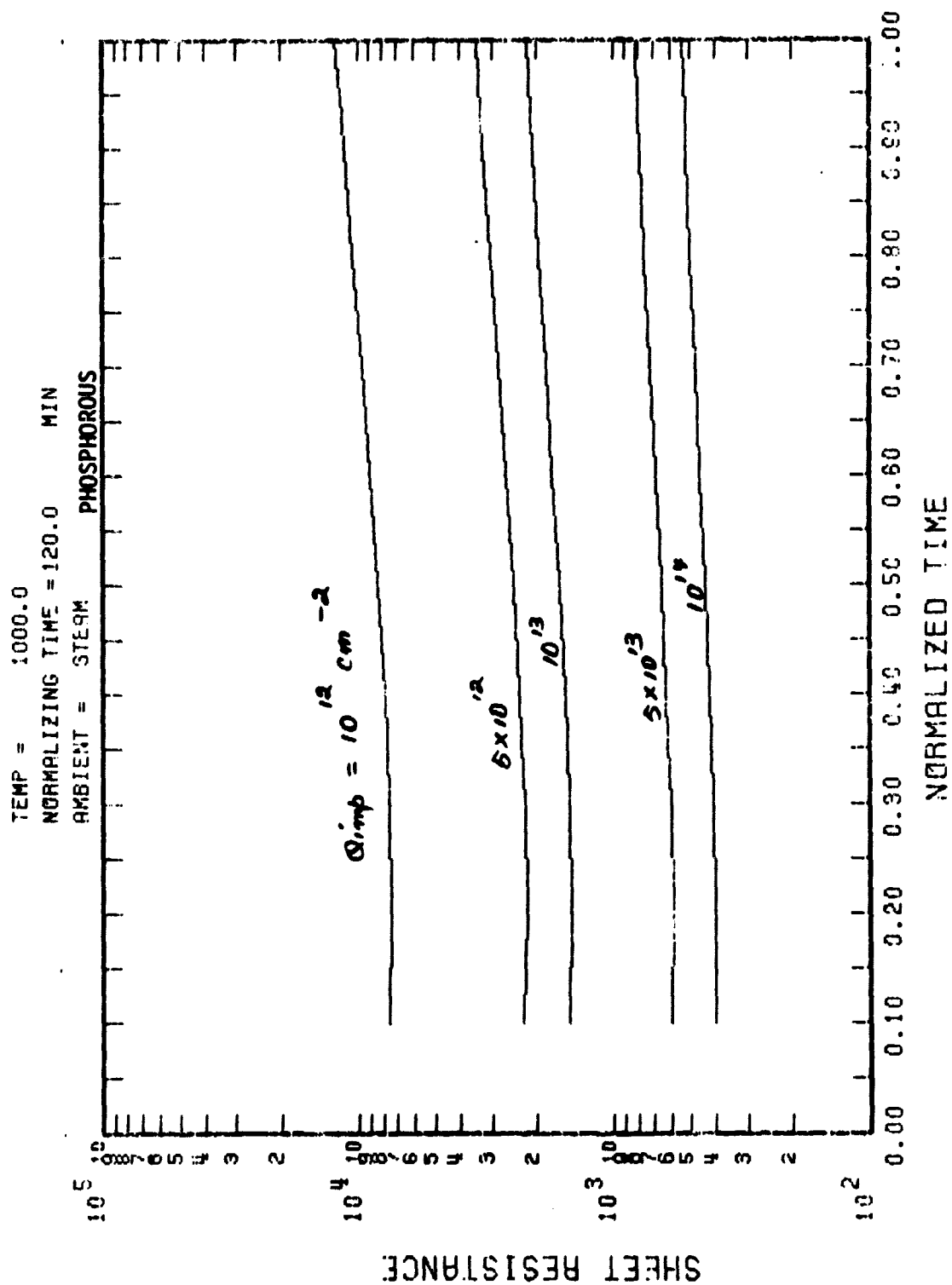


TEMP = 950.0
 NORMALIZING TIME = 483.3 MIN
 AMBIENT = STEAM PHOSPHOROUS



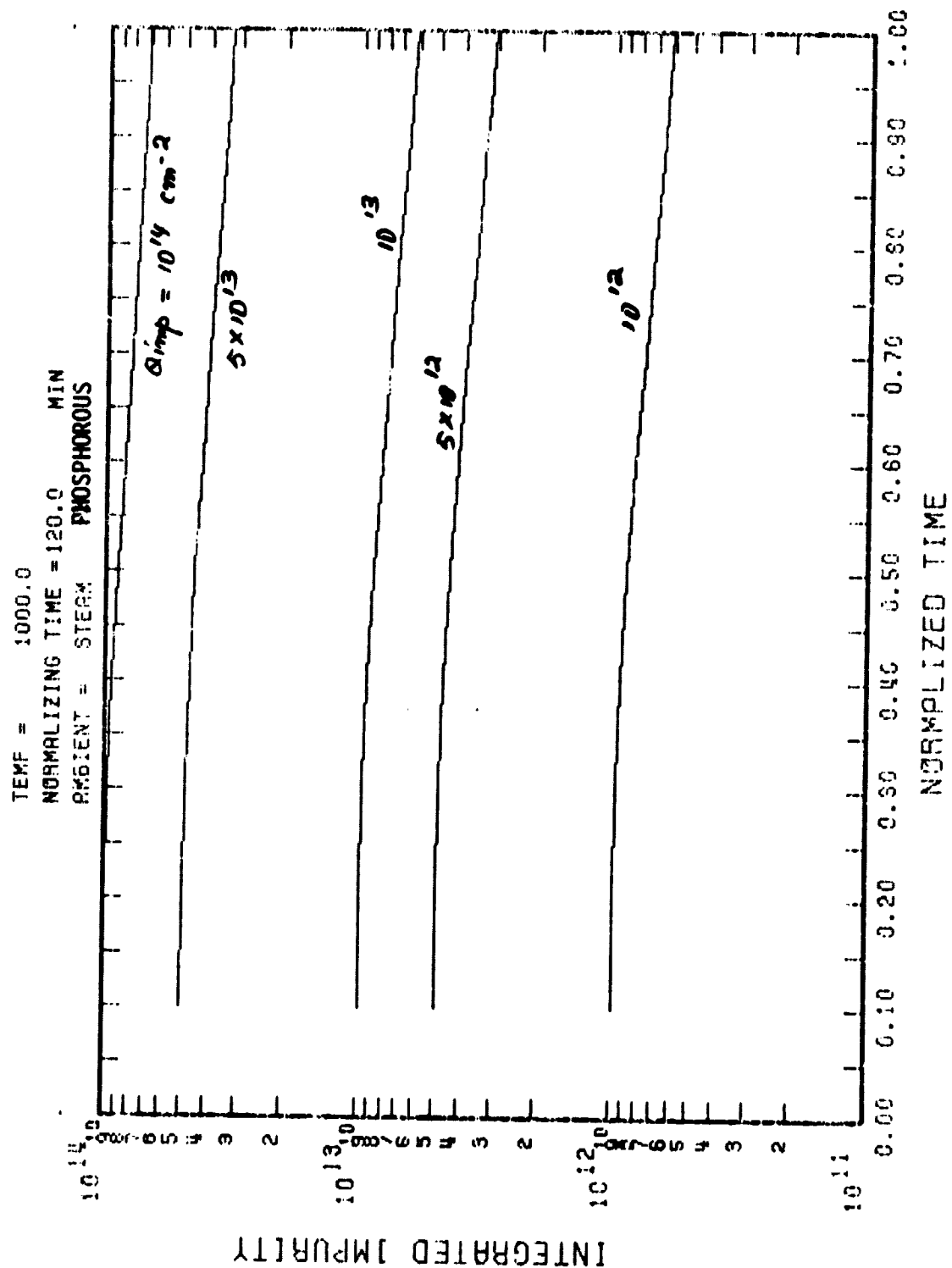






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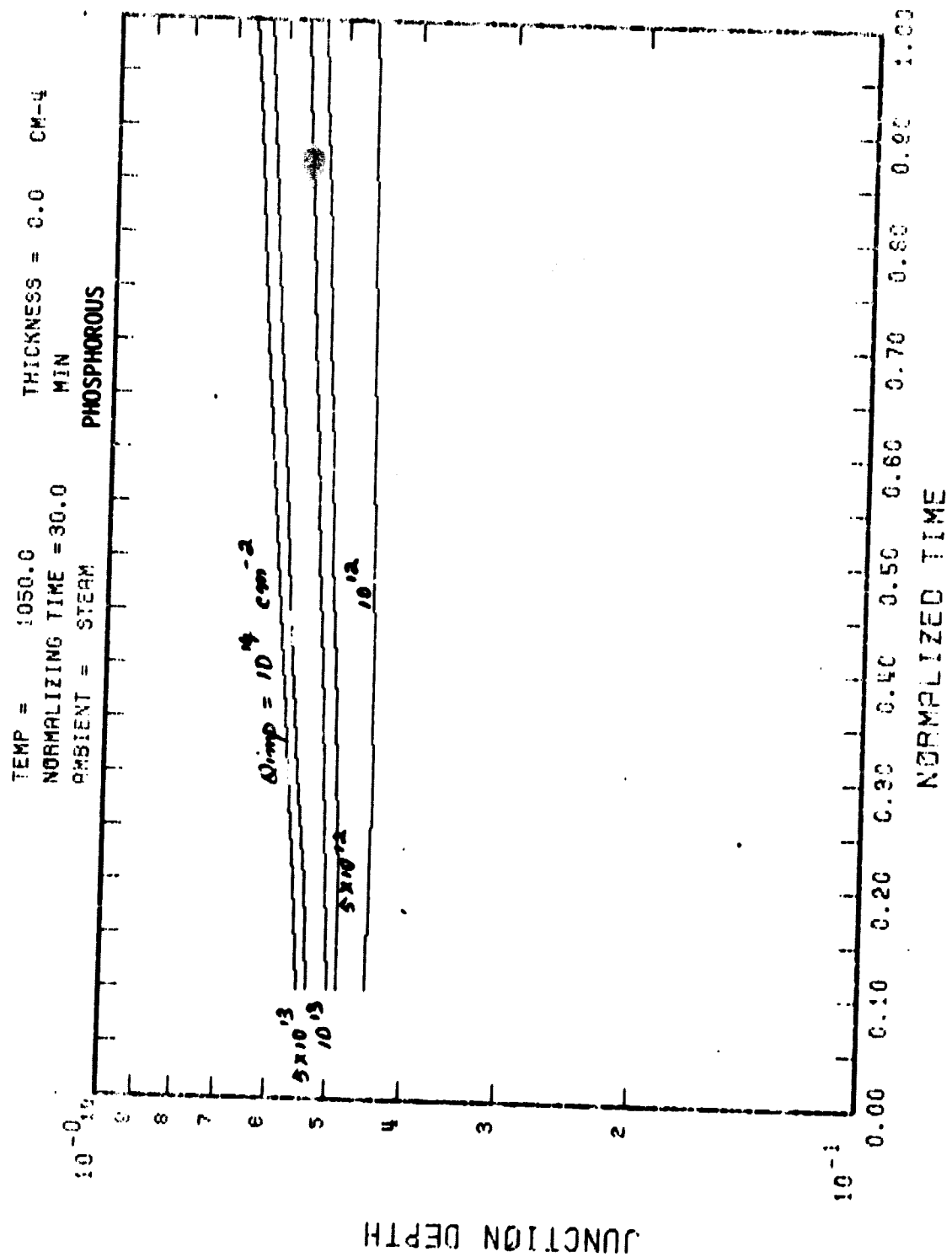
B 50



51

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B 51

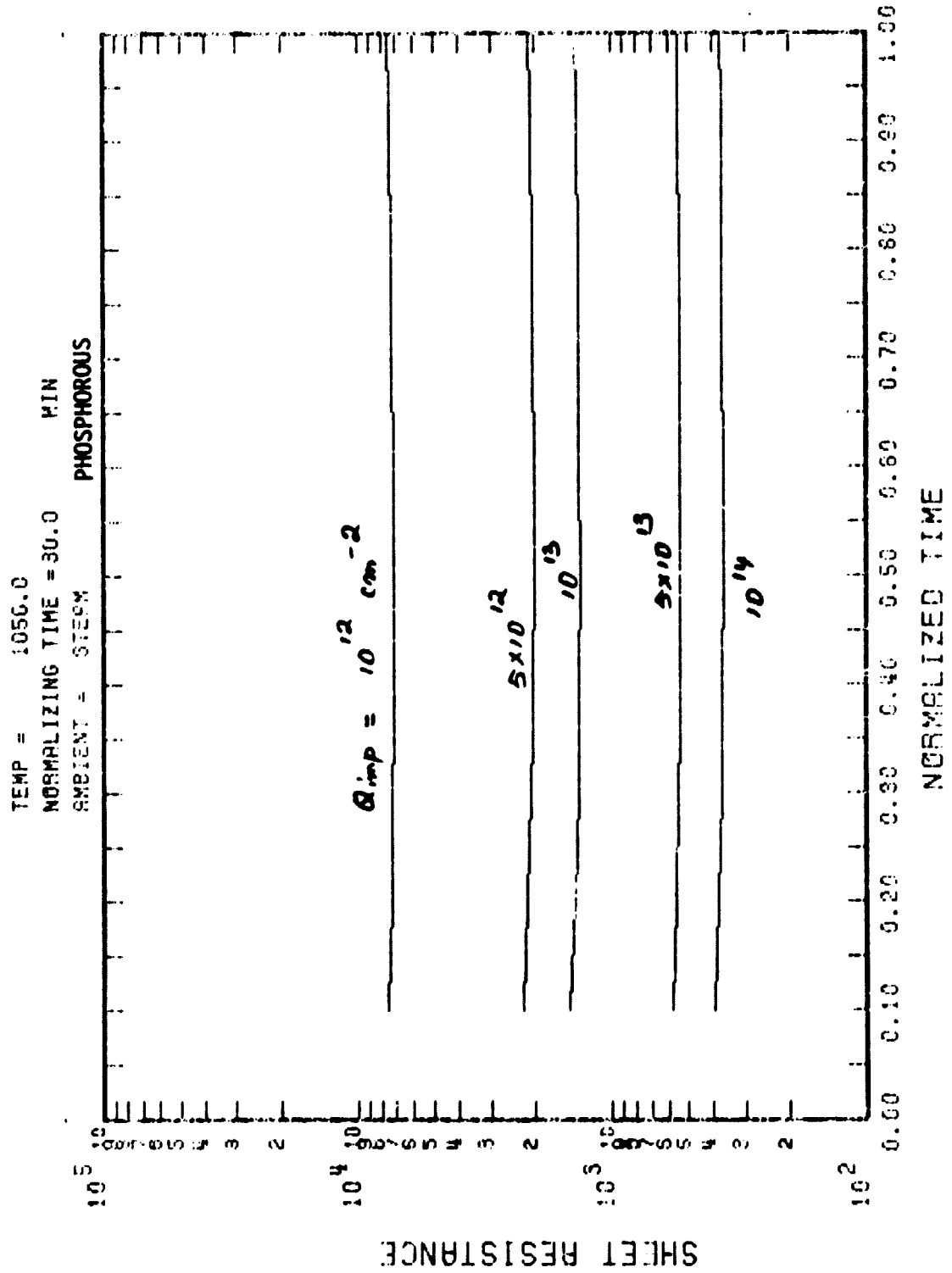


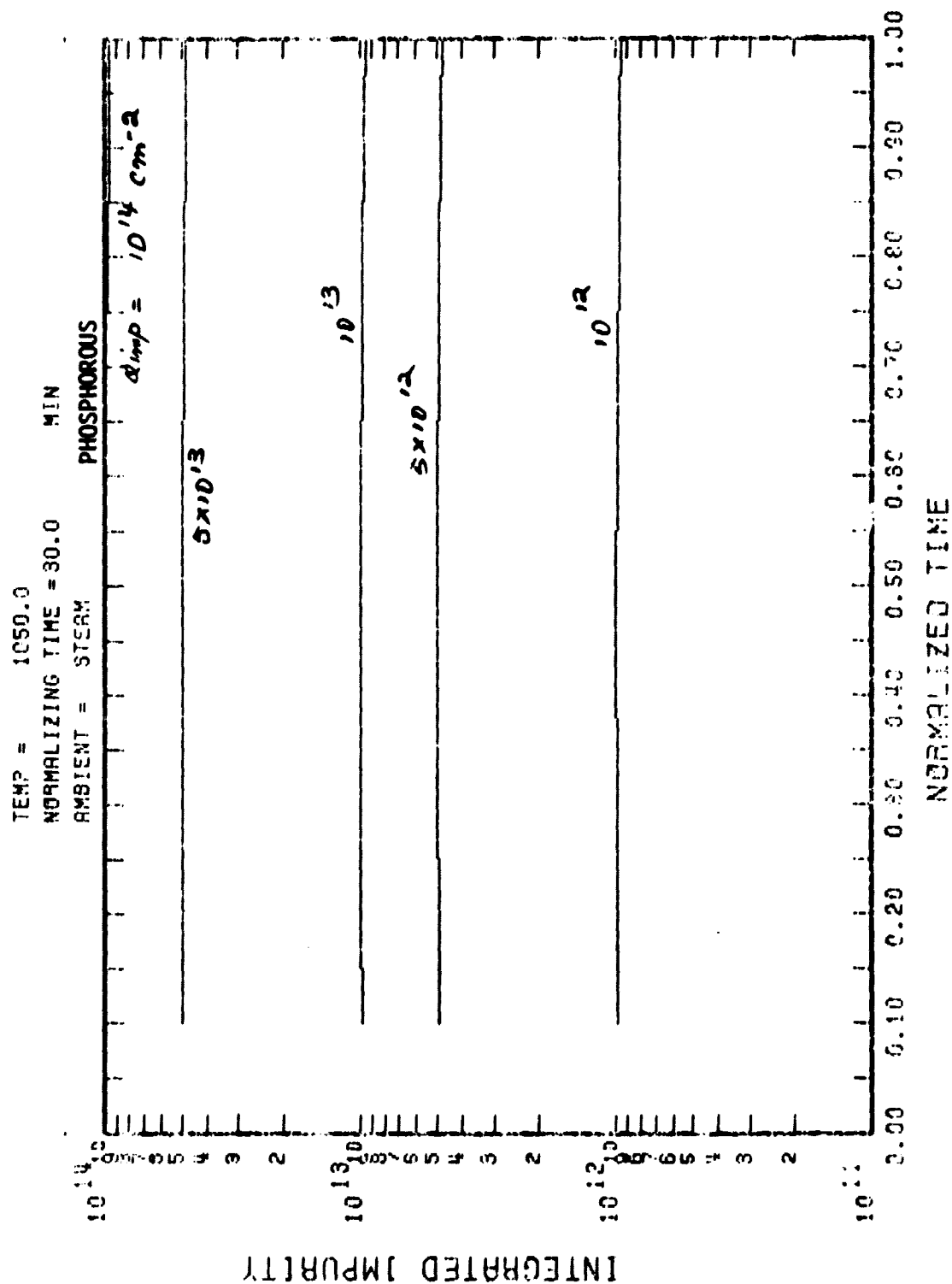
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52

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B 52






```

1 C *** SHRFUN PLOT PROGRAM ***
2
3 C
4 C *** DATA DECK ***
5
6 C *** 1ST CARD
7 NPLT = # OF DATA SETS FOR DIFF. VALUES OF IMPLNT. DOSES)
8 NSTP1 TO NSTP5 = # OF TIME STEPS FOR A VALUE OF NPLT (MAX. 5 VALUES)
9 FIELD 8110
10 C *** 2ND CARD, 4TH AND 6TH CARD
11 IXY = X AND Y AXIS LABELS RESPECTIVELY
12 1ST, 2ND AND 3RD PLOTS ARE NS, X, AND Q VS TIME PLOTS RESP.
13 JC0D = PUT 0 FOR NO GRID
14 FIELD 2(5A6).2110
15 C *** 3RD CARD
16 JGRID = # OF DIV. IN Y AXIS
17 IGRID = # OF DIV. IN X AXIS
18 NYSTP = SUBGRID DIV. IN Y AXIS
19 1 GIVES 1 SURGD.
20 NXSTP = SUBGRID DIV. IN X AXIS
21 2 GIVES 1 SURGD.
22 YMINV = MIN VAL IN Y AXIS
23 YMAXV = MAX VAL IN Y AXIS
24 XMINV = MIN VAL IN X AXIS
25 XMAXV = MAX VAL IN X AXIS
26 FIELD 1110.4E10.4
27 DIMENSION NS(10,100),XJ(10,100),Q(10,100),TIME(10,100)
28 DIMENSION XI(10,100)
29 DIMENSION IX(5),IY(5),IL(2),XO(10,100)
30 C *** READ IN DATA
31 READ 100,NPLT,NSTP1,NSTP2,NSTP3,NSTP4,NSTP5
32 DO 10 I=1,NPLT
33 IF(1.FQ.1) NSTP=NSTP1
34 IF(1.FQ.2) NSTP=NSTP2
35 IF(1.FQ.3) NSTP=NSTP3
36 IF(1.FQ.4) NSTP=NSTP4
37 IF(1.FQ.5) NSTP=NSTP5
38 DO 10 J=1,NSTP
39 READ(14,104) JMAX,IAMBNT
40 READ(14,101) TEMP,THAX,DELT,DELY,VDIST
41 READ(14,101) NS(1,J),XI(1,J),XJ(1,J),Q(1,J),TIME(1,J),XO(1,J)
42 IF(IAMBNT.EQ.1) I(1)= 'DRY OR'
43 IF(IAMBNT.EQ.1) I(2)= 'YGEN'
44 IF(IAMBNT.EQ.2) I(1)= 'STEAM'
45 IF(IAMBNT.EQ.2) I(2)= ' '
46 IF(IAMBNT.EQ.3) I(1)= 'NITROG'
47 IF(IAMBNT.EQ.3) I(2)= 'EN'
48 C
49 102 FORMAT(1H0,4E15.9)
50 101 FORMAT(2(5A6),2110)
51 103 FORMAT(4110.4E10.4)
52 104 FORMAT(1H0,8110)
53 105 FORMAT(2A6)
54 400 FORMAT(1H0,10X,'XMIN = ',5X,'XMAX = ',5X,'YMIN = ',5X,'YMAX = ',
55 //1H0,3X,4(F10.5,14))
56 C
57 DATA WGT,XMAX,YMAX/0.0075,7.0,5.0/
58 THAX=THAX/47.
59 IC=10
60 C *** INITIATE THE PLOT
61 DO 11 N=1,3
62 READ 102, (IX(I),I=1,6), (IY(I),I=1,5),JC0D
63 READ 103, IGRID,JGRID,NYSTP,NXSTP,YMINV,YMAXV,XMINV,XMAXV
64 PRINT 400,XMINV,XMAXV,YMINV,YMAXV
65 IF(JC0D.NE.0) IC0D=2
66 IF(JC0D.EQ.0) IC0D=3
67 CALL PLOTS(10,0,10,3)
68 CALL PLOT(1,5,1,0,-3)
69 C *** DRAW BORDER
70 CALL PLOT(0,0,YMAX,2,-1)
71 CALL PLOT(XMAX,YMAX,2,-1)
72 CALL PLOT(XMAX,0,2,-1)
73 CALL PLOT(0,0,2,-1)
74 C *** DRAW GRID
75 YDIV=YMAX/FLOAT(JGRID)
76 JK=1
77 DO 12 I=1,JGRID
78 DO 13 J=1,IC,NYSTP
79 VSPC=ALOG10(FLOAT(J*JK))-YDIV

```

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80 CALL PLOT(0.0,YSPC,3)
81 CALL PLOT(0.12,YSPC,2.0)
82 CALL PLOT(XMAX,0.12,YSPC,1.00)
83 13 CALL PLOT(XMAX,YSPC,2.0)
84 JK=JK+10
85 IGRID1=IGRID+NXSTP
86 IGRID2=IGRID1-1
87 XDIV=XMAX/FLOAT(IGRID1)
88 DO 14 I=1,IGRID2
89 XSPC=FLOAT(I)*XDIV
90 CALL PLOT(XSPC,0.0,3)
91 CALL PLOT(XSPC,0.12,2.0)
92 CALL PLOT(XSPC,YMAX,0.12,1.00)
93 14 CALL PLOT(XSPC,YMAX,2.0)
94 C *** ARG NUMBERS
95 VAL1=YMINV
96 JK=1
97 JGRD1=JGRD+1
98 DO 15 J=1,JGRD1
99 DO 17 J=1,IC,NYSTP
100 IF(1.E0,JGRD1,AND,J.NE.1) GO TO 17
101 YSPC=ALOG10(FLOAT(J*JK)*YDIV)
102 YSPC=YSPC
103 IF(J.E0.1) GO TO 100
104 VAL=FLOAT(J)
105 CALL NUMBER(-0.10,YSPC,0.0,VAL.N,0.1)
106 GO TO 17
107 200 VAL2=ALOG10(VAL)
108 CALL NUMBER(-0.50,YSPC,0.10,10.0,0.1)
109 CALL NUMBER(-0.35,YSPC,0.09,0.1,VAL2.0,0.1)
110 17 CONTINUE
111 VAL1=VAL1*10.
112 JK=JK+10
113 X=XMAX/FLOAT(IGRID)
114 IGRID3=IGRID+1
115 DO 18 I=1,IGRID3
116 XSPC=I*10/XDIV*NTSTP
117 XSPC=XSPC-0.2
118 VAL=XV*(I-1)
119 CALL NUMBER(XSPC,-0.20,0.1,VAL.N,0.2)
120 C *** PUT LABELS
121 CALL SYMBOL(0.0,1.0,0.1313,1.0,0.30)
122 CALL SYMBOL(2.00,0.0,0.0,0.1313,1.0,0.30)
123 CALL SYMBOL(2.0,0.0,0.0,MAT,TEMP,0.7)
124 CALL NUMBER(3.0,0.0,MAT,TEMP,0.1)
125 CALL SYMBOL(2.0,0.0,MAT,NORMALIZING TIME =
126 0.0,32)
127 CALL NUMBER(3.0,0.0,MAT,TMAX,0.1)
128 CALL SYMBOL(2.0,0.0,MAT,AMBIENT = 0.0,10)
129 CALL SYMBOL(3.0,0.0,MAT,IL,0.12)
130 IF(N.E0.2) CALL SYMBOL(4.0,0.0,MAT,THICKNESS =
131 0.0,23)
132 IF(N.E0.2) CALL NUMBER(5.0,0.0,MAT,YDIST,0.1)
133 C *** DRAW CURVES
134 YLOG=YMAX/FLOAT(JGRD1)
135 XVM=XMAX/XMAXV
136 YVM=Y1/YMINV
137 DO 22 I=1,NPLT
138 CALL PLOT(0.0,0.0,N,3)
139 IF(1.E0.1) NSTP=NSTP1
140 IF(1.E0.2) NSTP=NSTP2
141 IF(1.E0.3) NSTP=NSTP3
142 IF(1.E0.4) NSTP=NSTP4
143 IF(1.E0.5) NSTP=NSTP5
144 DO 21 J=1,NSTP
145 IF(J.E0.1) L=3
146 IF(J.NE.1) L=2
147 IF(1.AMBNT.NE.3) TIME(I,J)=TIME(I,J)/TIME(NPLT,NSTP)
148 XMOVE=TIME(I,J)*XV
149 IF(N.E0.3) GO TO 201
150 IF(N.E0.2) GO TO 202
151 YMOVE=YLOG*ALOG10(XS(I,J)*YVM)
152 GO TO 21
153 201 YMOVE=YLOG*ALOG10(Q(I,J)*YVM)
154 GO TO 21
155 202 YMOVE=YLOG*ALOG10(XJ(I,J)*YVM)
156 21 CALL PLOT(XMOVE,YMOVE,L,0)
157 IF(N.NE.2) GO TO 22
158 CALL PLOT(0.0,0.0,3)
159 DO 23 J=1,NSTP

```

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MIN°

CM=4°

```
160 IF(J.EQ.1) L=3
161 IF(J.NE.1) L=2
162 XMOVE=TIME(1,J)*XV1
163 XI(1,J)=XI(1,J)*(YDIST-0.45*XD(1,J))/1.E-4
164 IF(XI(1,J).LT.1.E-01) XI(1,J)=1.E-01
165 YMOVE=YLOG*ALOG10(XI(1,J)*YHVR)
166 23 CALL PLOT(XMOVE,YMOVE,L,0)
167 22 CONTINUE
168 CALL PLOT(0.,0.,999)
169 11 CONTINUE
170 STOP
171 END
```

MICRON=5n52(1).PARAM

```

1 SUBROUTINE PARAM(I,T)
2 C.....
3 C AFTER THAI AND MORIN AND MAITA.
4 C.....
5 IMPLICIT DOUBLE PRECISION (A-H,O-Z)
6 CI=1.E15
7 2 FG=1.21*7.1E-10*SQRT(CI)*(T)*(-.5)
8 EG=EG/(8.62E-5*(T))
9 CIOLD=CI
10 CI=3.87E16*((T)*.1.5)*EXP(-EG/7.)
11 R=CIOLD/CI
12 IF(R.LT.0.995.AND.R.GT.1.005) GO TO 2
13 RETURN
14 END
15 C.....

```

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```

1      DOUBLE PRECISION FUNCTION G(CN,JJ)
2      IMPLICIT DOUBLE PRECISION(A-H,O-Z)
3      C.....
4      C      IRWIN'S CONDUCTIVITY FORMULAS.
5      C.....
6      IF (JJ.EQ.1) GO TO 3
7      IF (CN.GT.0.0) A=1.0
8      IF (CN.GT.0.0) B=7.20-17
9      IF (CN.GT.1.50+14) A=0.65
10     IF (CN.GT.1.50+14) B=3.30-11
11     IF (CN.GT.2.40+18) A=0.832
12     IF (CN.GT.2.40+18) B=1.470-14
13     IF (CN.GT.1.50+19) A=0.966
14     IF (CN.GT.1.50+19) B=4.0-17
15     GO TO 5
16     3  IF (CN.GT.0.0) A=1.0
17     IF (CN.GT.0.0) B=2.0-16
18     IF (CN.GT.3.50+15) A=0.837
19     IF (CN.GT.3.50+15) B=6.970-14
20     IF (CN.GT.1.00+17) A=0.543
21     IF (CN.GT.1.00+17) B=6.930-9
22     IF (CN.GT.9.50+18) A=0.94
23     IF (CN.GT.9.50+18) B=2.0-16
24     IF (CN.GT.6.0+19) A=0.744
25     IF (CN.GT.6.0+19) B=1.430-12
26     IF (CN.GT.2.350+20) A=0.456
27     IF (CN.GT.2.350+20) B=1.040-6
28     5  G = B*(CN**A)
29     RETURN
30     END

```

11CRON=Sn52(1),OXDATA

```

1      SUBROUTINE OXDATA(AMANT,ORINT,T,R,C,M,KB)
2      C.....
3      C.....
4      C.....
5      C.....
6      C.....
7      C.....
8      C.....
9      C.....
10     C.....
11     IF(AMANT.EQ.1) GO TO 12
12     R=4.40277D-10*DEXP(-7945.74/T)
13     IF(ORINT.EQ.1) C=4.94558D-1*DEXP(-22184.07/T)
14     IF(ORINT.EQ.2) C=9.13646D-1*DEXP(-21835.113/T)
15     IF(ORINT.EQ.3) C=1.6000D*DEXP(-22396.838/T)
16     GO TO 14
17     12 CONTINUE
18     R=1.58507D-9*DEXP(-13916.6449/T)
19     IF(ORINT.EQ.1) C=2.0093D-1*DEXP(-24118.98/T)
20     IF(ORINT.EQ.2) C=4.33277D-1*DEXP(-24551.98/T)
21     IF(ORINT.EQ.3) C=7.09845D-1*DEXP(-24957.028/T)
22     14 CONTINUE
23     M1=33.3*DEXP(-0.52/(KR*T))
24     M3=20.0*DEXP(-0.67/(KR*T))
25     IF(ORINT.EQ.1) M=M1
26     IF(ORINT.EQ.2) M=(M1+M3)/2.0
27     IF(ORINT.EQ.3) M=M3
28     RETURN
29     END

```

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```

1  SUBROUTINE FRONT(IMAXI,JMAXI,LM,K,TEMP,DFI,DELT,JSTEP,
2  * KTYPE,KOTI,XDIST)
3      C
4      C C C
5      C SUR. FOR CALCULATING CONTOUR FRONT MOVEMENT DATA AND
6      C READING AND WRITING THE SAME ON FILE
7
8      IMPLICIT DOUBLE PRECISION(A-H,O-Z)
9      DIMENSION XFRONT(4), YFRONT(4)
10     DATA IDOL,IBLNK,ISTAR,IHS,IM,IMH/
11     IF(KTYPE.NE.1) GO TO 400
12
13     C
14     READ FILE
15
16     DO 60 KK=1,JSTEP
17         READ (9,390) MARK
18         IF (MARK.NE.IDOL) GO TO 50
19         READ(9,430) TEMP,DFI,DELT
20         READ(9,390) MARK
21     50     READ (9,430) (DIM,L=1,6)
22         READ (9,430) (DIM,L=1,6)
23         READ(9,420) IMAXI,JMAXI,K,LM
24     60     CONTINUE
25     RETURN
26
27     800 CONTINUE
28     DO 260 LL=1,6
29         CONVAL=10.0*FLOAT(70-LL+1)
30         XF=CONDEF(IMAXI,JMAXI,0,-JMAXI,0,0,CONVAL)
31         YF=CONDEF(IMAXI,JMAXI,-2,0,0,0,CONVAL)
32         IF (XF.EQ.0.0) GO TO 250
33         XFRONT(LL)=(XF-FLOAT(K))/(XDIST/FLOAT(IMAXI-1))
34     250     CONTINUE
35         IF (YF.EQ.0.0) GO TO 260
36         YFRONT(LL)=(YF-FLOAT(JMAXI)-YF)/FLOAT(JMAXI-1)
37     260     CONTINUE
38
39     C
40     STORE CONTOUR FRONT MOVEMENT DATA IF IFILE = 1
41
42     MARK=IDOL
43     IF (KOTI.GT.1) MARK=IBLNK
44     WRITE (9,390) MARK
45     IF (KOTI.GT.1) GO TO 270
46     WRITE(9,430) TEMP,DFI,DELT
47     MARK=IBLNK
48     WRITE(9,390) MARK
49     270 WRITE (9,430) (XFRONT(LL),LL=1,6)
50     WRITE (9,430) (YFRONT(LL),LL=1,6)
51     WRITE(9,420) IMAXI,JMAXI,K,LM
52     390 FORMAT (1H0,A6)
53     400 FORMAT (1H .3F10.1)
54     420 FORMAT (1H .415)
55     430 FORMAT (1H .6(E14.9,2X))
56     RETURN
57     END

```

MICRON=5052(1),FRPLOT

```

1  C *** PLOT PROGRAM FOR THE CONTOUR FRONT MOVEMENT ***
2
3  C
4  C READ IN FROM DATA DECK
5  C JSTEP= # OF TIME STEPS TO BE READ IN
6  C
7  C *TEMP = SIMULATION TEMPERATURE*,
8  C *DFI = 1/AMDA**2*,
9  C *DLT = TIME STEP*,
10
11  C
12  C DOUBLE PRECISION XFRONT(800,6),YFRONT(800,6)
13  C DOUBLE PRECISION TEMP,DFI,DLT
14  C DIMENSION TAU(800)
15  C DIMENSION IX(3),IY(3),IA(6)
16  C DATA IDOL,IBLNK,ICLAR,IMS,IM,IMH,
17  C DATA 1A/6HCONCEN,4MTRAT,10,6MN FRON,6MT MOVE,6HMENT P,6HLOT ;
18  C DATA IX/6HIN X D,6HIRFCT,6HON /
19  C DATA IY/6HIN Y D,6HIRFCT,6HON /
20  C 390 FORMAT(1H0,4A6)
21  C 420 FORMAT(1H ,4I5)
22  C 430 FORMAT(1H ,6(E14.9,2X))
23  C *** READ DATA FROM DECK
24  C READ 200, JSTEP
25  C 200 FORMAT(8I10)
26  C TIME=0.
27  C DO 1 KK=1, JSTEP
28  C READ(8,390) MARK
29  C IF(MARK.NE.IDOL) GO TO 5
30  C READ(8,430) TEMP,DFI,DLT
31  C READ(8,390) MARK
32  C 5 READ(8,430) (XFRONT(KK,LL),LL=1,6)
33  C READ(8,430) (YFRONT(KK,LL),LL=1,6)
34  C READ(8,420) IMAXI,IMAXI,LM
35  C TIME=TIME+DLT
36  C TAU(KK)=TIME
37  C 1 CONTINUE
38  C DATA HGT,XMAX,YMAX/D,875,7,0,5,0/
39  C *** INITIATE THE PLOT
40  C DO 80 N=1,2
41  C CALL PLOTS(10,0,10,0)
42  C CALL PLOT(1,5,1,5,-3)
43  C *** DRAW BORDER
44  C CALL PLOT(0,0,YMAX,2,-1)
45  C CALL PLOT(XMAX,YMAX,2,-1)
46  C CALL PLOT(XMAX,0,0,2,-1)
47  C CALL PLOT(0,0,0,2,-1)
48  C *** SCALE GRID
49  C TTAU=TAU(JSTEP)*100.
50  C IDIV=INT(TTAU)
51  C IS=IDIV/25*25+25
52  C TAUH=FLOAT(IS)/100.
53  C
54  C YY1=XFRONT(1,6)
55  C IF(N.EQ.2) YY1=YFRONT(1,6)
56  C DO 2 I=2,JSTEP
57  C YY2=XFRONT(I,6)
58  C IF(N.EQ.2) YY2=YFRONT(I,6)
59  C YYY=AMAX1(YY1,YY2)
60  C 2 YY1=YYY
61  C YAP=YYY*100.
62  C IYD=INT(YAP)
63  C IT=IYD/25*25+25
64  C YDHAX=FLOAT(IT)/100.
65  C *** DRAW GRID
66  C DX=XMAX/20.
67  C DO 10 I=1,19
68  C X=FLOAT(I)*DX
69  C CALL PLOT(X,0,3)
70  C CALL PLOT(X,YMAX,2,1)
71  C 10 CONTINUE
72  C DY=YMAX/20.
73  C DO 20 J=1,19
74  C Y=FLOAT(J)*DY
75  C CALL PLOT(0,0,Y,3)
76  C CALL PLOT(XMAX,Y,2,1)
77  C 20 CONTINUE
78  C *** ERASE LABEL AREA
79  C DO 30 I=3,14
80  C XX=(I-1)*DX
81  C CALL PLOT(XX,17,0,0,Y,3)

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80      30 CALL PLOT(X,19.5*DY,12)
81      DO 40 I=19,20
82      YY=(I-1)*DY
83      CALL PLOT(X,YY,3)
84      40 CALL PLOT(14.*DX,YY,12)
85      C *** PUT SYMBOL
86      CALL SYMBOL(0.5,4.7,0.1313,1A,0.0,33)
87      IF(N.EQ.2) IX=1Y
88      CALL SYMBOL(1.6,4.45,0.1313,1X,0.0,14)
89      C *** AXES NUMBERS
90      Y=0.2
91      DO 50 I=1,11
92      X=FLOAT(I-1)*2.*DX=.125
93      VAL=FLOAT(I-1)*TAUM/10.
94      50 CALL NUMBER(X,Y,HGT,VAL,0.0,2)
95      X=0.5
96      DO 60 J=1,21
97      Y=FLOAT(J-1)*DY=.043
98      VAL=FLOAT(J-1)*YDMAX/20.
99      60 CALL NUMBER(X,Y,HGT,VAL,0.0,2)
100     CALL SYMBOL(-.75,2.1,0.1313,'DISTANCE',90.,8)
101     CALL SYMBOL(2.1,-.5,0.1313,'NORMALIZED TIME - TAU',0.,21)
102     DO 70 LL=1,6
103     CALL PLOT(0.0,0.0,3)
104     XMOVE=0.
105     CALL PLOT(TAU,XMOVE,2,0)
106     DO 70 HL=1,JSTEP
107     TAUP=TAU(HL)*XMAX/TAUM
108     XMOVE=XFRONT(HL,LL)*YMAX/YDMAX
109     IF(N.EQ.2) YMOVE=YFRONT(HL,LL)*YMAX/YDMAX
110     IF(TAU.GT.0.0.AND.YMOVE.EQ.0.0.AND.N.EQ.2) GO TO 70
111     IF(N.EQ.2) XMOVE=YMOVE
112     IF(XMOVE.LT.0.) XMOVE=0.C
113     CALL PLOT(TAUP,XMOVE,2,0)
114     70 CONTINUE
115     CALL PLOT(0.,0.,9*9)
116     80 CONTINUE
117     STOP
118     END

```

MICRON*5052(1),SHFILE

```

1  SUBROUTINE SHFILE(TIME,DELT,DELY,TEMP,THAX,RS,YJ1,YJUNC,0
2  * ,JMAX1,YDIST,X0,IAHRNT)
3
4      C
5      C
6      C
7      IMPLICIT DOUBLE PRECISION(A-H,O-Z)
8      WRITE(13,200) JMAX1,IAHRNT
9      200 FORMAT(1H0,8I10)
10     WRITE(13,100) TEMP,THAX,DELT,DELY,YDIST
11     WRITE(13,100) RS,YJ1,YJUNC,0,TIME,X0
12     100 FORMAT(1H0,4E15.9)
13     RETURN
14     END

```

```

MICRON=SOS2(1).OUTPUT
1  SURROUTINE OUTPUT(X,Y,IMAXI,JMAXI,K,LM,JJ,TIME,YDIST,
2  *ID,ITIME,XO,PTIME,DTIME,IAMBNT)
3
4  C
5  C
6  C
7  C
8  C
9  C
10  C
11  C
12  C
13  C
14  C
15  C
16  C
17  C
18  C
19  C
20  C
21  C
22  C
23  C
24  C
25  C
26  C
27  C
28  C
29  C
30  C
31  C
32  C
33  C
34  C
35  C
36  C
37  C
38  C
    IMPLICIT DOUBLE PRECISION(A-H,O-Z)
    COMMON /CON/CB1(65,64)
    DIMENSION X(1),Y(1),ID(15),XO(1)
    IMAX=IMAXI-1
    JMAX=JMAXI-1
    PRINT 106, ID, ITIME
    PRINT 100, LM, TIME, PTIME, DTIME, K, X(K), IMAXI, X(IMAXI)
    PRINT 101, (N,N=2,IMAXI,2)
    PRINT 102, (X(I),I=2,IMAXI,2)
    PRINT 105
    W1=YDIST-0.45*XO(2)
    DO 2 J=JMAXI,1,-1
    Q=YDIST-Y(J)
    IF(IAMBNT.NE.3) Q=(JMAXI-J)*41./FLOAT(JMAXI-1)
    2 PRINT 103, Q,(CB1(I,J),I=2,IMAXI,2)
    PRINT 108, (XO(I),I=2,IMAXI,2)
    IF(IAMBNT.NE.3) PRINT 109, W1
109 FORMAT(/,1H0,10X,'SI FILM' = ,F10.5)
108 FORMAT(1H0,10X,'OXIDE THICKNESS IN CM' = ,F10.13X,11(1PF10.3))
    PRINT 104, JJ
100 FORMAT(1H0,10X,12UTIME STEP = ,14,3X,7HTIME = ,F10.3,
    *5X,'ELAPSED TIME IN SEC.' = ,2X,'PREDEP' = ,F10.3,2X,'DRIVE IN' = ,
    * F10.3//
    *10X,'OXIDE POSITION'/
    *10X,'X( ,12.' = ,E6.2,2X,'X( ,12.' = ,E6.2//)
101 FORMAT(/,1H0, 3HI = ,6X,12110)
102 FORMAT(/,1H0,3X,3HX = ,7X,12(1PF10.3))
103 FORMAT(1H, 2X,'Y= ,1PF7.1,2X,11(1PF10.3))
104 FORMAT(/,1H0,'NO. OF ITERATION' = ,15)
105 FORMAT(1H0)
106 FORMAT(1H1,10X,15A4,T90,'TIME',A6)
    RETURN
    END

```

PRT SOS2.PLOT-CONTOUR,,SUBION,,TRIANG,,ARC,,XYZ,,PLOT,,CONDEP,,MAIN

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11CRON=5052(1),PLOT=CONTOUR

```

1  SURROUTINE PLTCON(A,CONVAL,NC,IK,JK)
2
3  C
4  C ISOCONCENTRATION PLOT SUBPROGRAM /
5  C
6  DIMENSION A(4,4),X(1000,3),Y(1000,3),NV(1000)
7  DIMENSION CS(2,3),CT(2,2,4),OT(2,4),B(4),OS(2,3)
8  DATA ZERO/1.0E-20/
9  DATA ((CS(I,J),J=1,3),I=1,2)/0.5,-1.0,0.5,-0.5,0.0,0.5/
10 DATA ((CT(I,J,K),K=1,4),J=1,2),I=1,2)/1.0,0.0,-1.0,0.0,0.0,1.0,0.0,0.0/
11 DATA ((OT(I,J),J=1,4),I=1,2)/0.0,0.0,1.0,1.0,0.0,0.1,0.0,0.0/
12 DATA ((OS(I,J),J=1,3),I=1,2)/0.5,1.0,0.0,0.5,0.0,0.0,0.0/
13 DATA XMAX,YMAX/8.0,4.0/
14 NCM=NC-1
15 CONTUR=ALOG10(CONVAL)
16 C * RESET PEN TO ORIGIN
17 C * CALL PLOT(0,0,0,0,3)
18 C * COMPUTE SCALING FACTORS
19 SCALX=XMAX*1.5/(IK-2)
20 SCALY=YMAX/(JK-1)
21 C * START CONTOUR SEARCH
22 NT=0
23 IL=IK-1
24 JL=JK-1
25 DO 50 I=2,IL
26 DO 50 J=1,JL
27 C * LOCATE SQUARE CROSSINGS
28 II=I-2
29 JJ=J-1
30 B(1)=0.25*(ALOG10(A(I,J))+ALOG10(A(I+1,J))+ALOG10(A(I,J+1))+
31 *ALOG10(A(I+1,J+1)))
32 R(1)=10.0**R(1)
33 R(4)=R(1)
34 C * LOCATE TRIANGLES
35 DO 20 K=1,4
36 NP=1
37 GO TO (21,22,23,24),K
38 21 R(2)=A(I+1,J)
39 R(3)=A(I,J)
40 GO TO 30
41 22 R(2)=A(I,J)
42 R(3)=A(I,J+1)
43 GO TO 30
44 23 R(2)=A(I,J+1)
45 R(3)=A(I+1,J+1)
46 GO TO 30
47 24 R(2)=A(I+1,J+1)
48 R(3)=A(I+1,J)
49 GO TO 30
50 C * LOCATE INTERSECTIONS
51 DO 35 M=1,3
52 IF (CONVAL*LT.AMIN(B(M),B(M+1)).OR.CONVAL*GT.AMAX(B(M),B(M+1)))
53 * GO TO 35
54 NP=NP+1
55 RB=ALOG10(B(M+1))-ALOG10(B(M))
56 IF (ABS(RB).GT.2*FRO) GO TO 33
57 R=0.5
58 GO TO 34
59 33 DB=CONTUR-ALOG10(R(M))/RB
60 34 CONTINUE
61 TX=OS(1,M)+CS(1,M)*D
62 TY=OS(2,M)+CS(2,M)*D
63 X(INT+1,NP)=OT(1,K)*CT(1,1,K)*TX+CT(1,2,K)*TY+11
64 Y(INT+1,NP)=OT(2,K)*CT(2,1,K)*TX+CT(2,2,K)*TY+JJ
65 35 CONTINUE
66 IF (NP.LE.1) GO TO 40
67 NT=NT+1
68 NV(INT)=NP
69 40 CONTINUE
70 50 CONTINUE
71 C * SCALE POINTS
72 IF (NT.EQ.0) GO TO 80
73 DO 65 K=1,NT
74 NM=NV(K)
75 DO 65 L=1,NM
76 X(K,L)=X(K,L)*SCALX
77 Y(K,L)=Y(K,L)*SCALY
78 65 CONTINUE
79 C * PLOT CONTOUR

```

```
80      DO 71 K=1,NT
81      NM=NV(K)
82      CALL PLOT(X(K,1),Y(K,1),3)
83      IF (MOD(K,10).EQ.0) CALL SYMBOL(X(K,1),Y(K,1),0,10,NCM,0,0,-1)
84      DO 71 L=2,NM
85      CALL PLOT(X(K,L),Y(K,L),2)
86      IF (NM.EQ.3) CALL PLOT(X(K,1),Y(K,1),2)
87      71 CONTINUE
88      C  9 MOVE PEN TO ORIGIN
89      80 CALL PLOT(0.0,0.0,3)
90      RETURN
91      END
```

MICRON=5052(1).TRIDAG

```

1 SUBROUTINE TRIDAG(JF,I)
2 C.....
3 IMPLICIT DOUBLE PRECISION (A-H,O-Z)
4 COMMON /TRI/ A(64),B(64),C(64),D(64),V(64)
5 C
6 DIMENSION GAMMA(64),BETA(64)
7 BETA(JF)=B(JF)
8 GAMMA(JF)=D(JF)/BETA(JF)
9 JFP=JF+1
10 DO 100 I=JFP,L
11 BETA(I)=B(I)-A(I)*C(I-1)/BETA(I-1)
12 100 GAMMA(I)=(D(I)-A(I)*GAMMA(I-1))/BETA(I)
13 LAST=L-JF
14 V(L)=GAMMA(L)
15 DO 200 K=1, LAST
16 I=L-K
17 200 V(I)=GAMMA(I)-C(I)*V(I+1)/BETA(I)
18 RETURN
19 END

```

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MICRON=SnS2(1).SUBION

```

1 SUBROUTINE SUBION(IMAXI,JMAXI,K,V,YDIST,CSTOP)
2 C.....
3 C SUBROUTINE FOR GENERATING ION IMPLANT DATA
4 C.....
5 IMPLICIT DOUBLE PRECISION(A-H,O-Z)
6 COMMON /CON/CR1(64,64)
7 DIMENSION Y(1)
8 ISS=0
9 JM=JMAXI/2
10 IF(Y(JM).LT.1.D-3) ISS=1
11 READ 100,CHAX,RP,DRP,VOLT
12 100 FORMAT(1E15.6,F10.5)
13 PRINT 200,CHAX,RP,DRP,VOLT,CSTOP
14 200 FORMAT(//1H0,CHAX,RP,DRP,VOLT,CSTOP,CM=3,32,RP='E10.5,MICRON';
15 1H,DRP='E10.5,MICRON',71H,ION IMPLANTATION WITH
16 1H ION IMPLANT AT,F10.5,KFV,5X,CSTOP='E15.6)
17 IF(ISS.EQ.1) RP=RP*1.4
18 IF(ISS.EQ.1) DRP=DRP*1.D-4
19 DO 1 J=1,JMAXI
20 1 CB1(1,J)=CHAX*DEXP(-0.5*((YDIST-Y(J)-RP)/DRP)**2)
21 DO 2 J=1,JMAXI
22 2 CB1(1,J)=CB1(1,J)
23 2 CONTINUE
24 RETURN
25 END

```

MICRON=SnS2(1).ABC

```

1 SUBROUTINE ABC(IMAXI,JMAXI,X,V,LM,TIME,K,DFI,TEMP,TMAX,KOTI,XO,
2 YDIST,IAMANT)
3 C.....
4 C SUBROUTINE WRITES TRANSIENT DATA ON DATA FILE ON UNIT 11
5 C.....
6 DOUBLE PRECISION CR1,X,V,TIME,TEMP,TMAX,DFI,XO,YDIST
7 COMMON /CON/CR1(64,64)
8 DIMENSION XO(1)
9 DIMENSION Y(1),V(1)
10 DATA IDOL,IRLNK/1W5,1H /
11 KOTI=KOTI+1
12 MARK=IDOL
13 IF(KOTI.GT.1) MARK=IRLNK
14 WRITE(11,400) MARK
15 400 FORMAT(1H0,A4)
16 IF(KOTI.GT.1) GO TO 2
17 WRITE(11,100) DFI,TMAX,TEMP,YDIST
18 WRITE(11,200) K,IMAXI,JMAXI,IAMANT
19 200 FORMAT(1H,8110)
20 WRITE(11,100) (X(1),I=2,IMAXI)
21 WRITE(11,100) (Y(1),I=1,JMAXI)
22 MARK=IRLNK
23 WRITE(11,400) MARK
24 2 CONTINUE
25 WRITE(11,200) LM
26 WRITE(11,100) VIMP
27 DO 1 J=JMAXI,1,-1
28 1 WRITE(11,100) (CB1(1,J),I=2,IMAXI)
29 WRITE(11,100) (XO(1),I=2,IMAXI)
30 100 FORMAT(1H,6E15.9)
31 PRINT 300, KOTI
32 300 FORMAT(1H0,10X,'KOTI = ',110/)
33 RETURN
34 END

```

MICRON=5052(1),XYZ

```

1 SUBROUTINE XYZ(IMAXI,JMAXI,X,Y,LM,TIME,K,DFI,TEMP,TMAX,KNTI,XO,
2 YDIST,IAMBNT)
3 C.....
4 C
5 C SUBROUTINE READS THE TRANSIENT DATA FILE ON UNIT 11
6 C
7 DOUBLE PRECISION PBI,X,Y,TIME,TEMP,TMAX,DFI,XO,YDIST
8 COMMON /CON/CR1(64,64)
9 DIMENSION XO(1)
10 DIMENSION X(1),Y(1)
11 DATA IDOL,IDLNR/148,14 /
12 DO 3 KLM=1,KNTI
13 READ(11,30) MARK
14 IF(MARK.NE.IDOL) GO TO 5
15 READ(11,100) DFI,TMAX,TEMP,YDIST
16 READ(11,200) K,IMAXI,JMAXI,IAMBNT
17 100 FORMAT(IH,5E15.9)
18 200 FORMAT(IH,8I10)
19 READ(11,100) (X(1),I=2,IMAXI)
20 READ(11,100) (Y(1),I=1,JMAXI)
21 READ(11,100) MARK
22 5 CONTINUE
23 READ(11,200) LM
24 READ(11,100) TIME
25 DO 1 J=JMAXI,1,-1
26 1 READ(11,100) (CB1(I,J),I=2,IMAXI)
27 READ(11,100) (XO(1),I=2,IMAXI)
28 3 CONTINUE
29 400 FORMAT(IHO,A4)
30 C APPLY PERIODIC B.C.
31 IMAX2=IMAXI-1
32 IMAX=IMAXI-1
33 DO 7 J=1,JMAXI
34 7 (CB1(I,J)=CB1(I,J)
35 (CB1(IMAX2,J)=CB1(IMAX,J)
36 RETURN
37 END

```



```

1 SUBROUTINE PLOT(CS,IMAX1,JMAX1,N)
2 C.....
3 C
4 C SUBROUTINE PLOTS THE TWO DIMENSIONAL PROFILE
5 C IN THE OUTPUT PRINTOUT IF IPLOT = 1
6 C.....
7 C
8 DOUBLE PRECISION CBL,C5
9 COMMON /CON/CBL(64),C5
10 DIMENSION SYMBL(21),ULINE(43)
11 DIMENSION IX(32)
12 DATA SYMBL/1HA,1H ,1HR,1H ,1HC,1H ,1HD,1H ,1HE,1H ,1HF,1H ,
13 1HG,1H ,1HH,1H ,1HI,1H ,1HJ,1H ,1HK/
14 DATA DOT,STAR/1H ,1H/,KP/21/
15 DATA IX/6*1H , 1HY,1H ,1HA,1HX,1HI,1HS,20*1H /
16 IMAX=IMAX1-1
17 PRINT 11
18 AT=ALOG10(2.2D11)
19 FACT=(ALOG10(CS)-AT)/(FLOAT(KP)-1)
20 K=0
21 DO 2 J=JMAX1,1,-1
22 DO 1 I=2,IMAX1
23 IF(CBL(I,J).LE.0.) GO TO 3
24 K=((ALOG10(CBL(I,J))-AT)/FACT)+1.0
25 3 CONTINUE
26 IF(K.LT.1) ULINE(I)=DOT
27 IF(K.GE.1.AND.K.LE.KP) ULINE(I)=SYMBL(K)
28 1 IF(K.GT.KP) ULINE(I)=STAR
29 L=JMAX1+1-J
30 2 PRINT 10,IX(L), (ULINE(I),I=2,IMAX1),(ULINE(I),I=IMAX1,2,-1)
31 PRINT 12
32 PRINT 13
33 PRINT 14,SYMBL(KP),CS
34 KD=KP-1
35 DO 4 I=KD,1,-1
36 CBL=10.**((I-1)*FACT+AT)
37 CBH=10.**((I*FACT+AT)
38 4 PRINT 15, SYMBL(I),CBH,CBL
39 PRINT 16
40 10 FORMAT(1H ,A1,IX,1H),70A1)
41 11 FORMAT(1H ,1IMPURITY CONCENTRATION PROFILE'/
42 1HO,41(1HW),///)
43 12 FORMAT(1H ,IX,50(1H-)//1H ,15X,'X AXIS')
44 13 FORMAT( //1HO,'SYMBOLIC REPRESENTATION OF CONCENTRATION RANGES',
45 1HO,10,'SYMBOLIC REPRESENTATION OF CONCENTRATION RANGES',
46 19(1H-)//1HO,T13,1H.,T29,'AT CS = ',F10.3)
47 14 FORMAT(1H ,T13,A1,T29,'AT CS = ',F10.3)
48 15 FORMAT(1H ,T13,A1,3X,'LESS THAN',E10.3,3X,'GREATER THAN OR EQUAL TO',
49 1O,F10.3)
50 16 FORMAT(1H ,T13,1H.,T29,'BELOW 1.0DOE11')
51 RETURN
52 END

```

MICRON=5052(1).CONDEP

```

1      FUNCTION CONDEP(M,N,I,J,MIN,MAX,CONVAL)
2      C* LOCATES CONCENTRATION CONTOURS ALONG EITHER
3      C* A VERTICAL OR HORIZONTAL GRID LINE, EITHER
4      C* LINEAR OR LOGRITHMIC INVERSE INTERPOLATION
5      C* CAN BE USED.
6      C*
7      C* A      - ARRAY BEING CONTOURED (DIMENSIONED
8      C*          (M,N) IN CALLING PROGRAM
9      C*
10     C* I,J    - NON-ZERO VALUE SPECIFIES GRID LINE
11     C*          TO BE CONTOURED. POSITIVE VALUE FOR
12     C*          LINEAR INTERPOLATION, NEGATIVE FOR
13     C*          LOGRITHMIC INTERPOLATION. EITHER
14     C*          I OR J MUST BE ZERO.
15     C* CONVAL- CONTOUR VALUE
16     C*
17     C* MIN,    - MINIMUM AND MAXIMUM SUBSCRIPTS OF
18     C*          GRID LINE TO BE CONTOURED. (MAY BE
19     C*          ZERO IF ENTIRE GRID LINE IS TO BE
20     C*          CONTOURED.)
21     C* CONDEP- POSITION OF CONVAL ON GRID LINE. IF
22     C*          CONVAL IS OUT OF RANGE OF GRID LINE
23     C*          VALUES CONDEP RETURNS A VALUE OF
24     C*          ZERO.
25     C*
26     IMPLICIT DOUBLE PRECISION(A-H,O-Z)
27     COMMON /CON/A(64,64)
28     DO 100 I=1,M
29     DO 100 J=1,N
30     IF (A(I,J).LT.1.D-700) A(I,J)=1.D-100
31     ILOG=1
32     IF (I.NE.0) GO TO 10
33     JINC=1
34     JMIN=MIN
35     JMAX=MAX-1
36     IF (MIN.EQ.0) JMIN=1
37     IF (MAX.EQ.0) JMAX=M-1
38     IF (J.LT.0) ILOG=-1
39     JINC=0
40     JMIN=ABS(J)
41     JMAX=JMIN
42     GO TO 20
43     10 CONTINUE
44     JINC=1
45     JMIN=MIN
46     JMAX=MAX-1
47     IF (MIN.EQ.0) JMIN=1
48     IF (MAX.EQ.0) JMAX=N-1
49     IF (I.LT.0) ILOG=-1
50     JINC=0
51     JMIN=ABS(I)
52     JMAX=JMIN
53     20 CONTINUE
54     CONDEP=0.0
55     DO 45 II=JMIN,JMAX
56     DO 40 JJ=JMIN,JMAX
57     IF (CONVAL.LT.AMINI(A(II,JJ),A(II+IINC,JJ+JINC)))
58     1.0R.CONVAL.GT.AMAX(A(II,JJ),A(II+IINC,JJ+JINC)))
59     2GO TO 40
60     IF (ILOG.LT.0) GO TO 30
61     CONDEP=((CONVAL-A(II,JJ))/(A(II+IINC,JJ+JINC)-A(II,JJ)))
62     1+FLOAT(II+IINC+JJ+JINC)
63     RETURN
64     30 CONTINUE
65     CONLOG=ALOG10(CONVAL)
66     CONDEP=((CONLOG-DLOG10(A(II,JJ)))/(DLOG10(A(II+IINC,JJ+JINC))-
67     DLOG10(A(II,JJ))))+FLOAT(II+IINC+JJ+JINC)
68     RETURN
69     40 CONTINUE
70     45 CONTINUE
71     RETURN
72     END

```

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OF POOR QUALITY

MICRON=Sn52(1).MAIN

```

1 C.....
2 C.....
3 C.....
4 C.....
5 C.....
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7 C.....
8 C.....
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78 C.....
79 C.....

```

PROCSIM 11

SOLUTION OF DIFFUSION PROBLEM FOR SILICON ON SAPPHIRE
*** NORMALIZED SOLUTION ***

DATA IS READ FROM DECK IN FOLLOWING SEQUENCE:

FIRST CARD:
LIST - # OF TIME STEPS TO BE SKIPPED WHILE PRINTING
IFILE - PUT 1 TO WRITE ON FILE AND ALSO TO LOCATE
CONTOUR POSITION, CONTOUR FRONT MOVEMENT DATA IS
WRITTEN ON UNIT 9 AND CONCENTRATION PROFILE IS
WRITTEN ON UNIT 11.
LFILE - # OF TIME STEPS TO BE SKIPPED WHILE WRITING ON FILE
IPLOT - PUT 1 TO PLOT PROFILE IN PRINT OUT
IREAD - PUT 1 TO READ DATA FROM FILE
- PUT 2 TO READ ION IMPLANT DATA AND TO
DO REDISTRIBUTION.
JSTEP - # OF DATA STEPS TO BE READ FROM FILE IF IREAD = 1
IMAXI, JMAXI - # OF GRID POINTS IN X AND Y DIRECTIONS
RESPECTIVELY. CHECK DIMENSION BEFORE CHANGING
FORMAT FIELD - 8110

SECOND CARD:
JSTP - PUT 0 IF CONST. SOURCE DIFF. IS DESIRED.
- PUT 1 IF REDISTRIBUTION IS DESIRED.
- PUT 2 IF TWO-STEP DIFF. IS DESIRED
ORINT - PUT 1 FOR 100 CRYSTAL ORIENTATION
- PUT 2 FOR 110 CRYSTAL ORIENTATION
- PUT 3 FOR 111 CRYSTAL ORIENTATION
AMRNT - PUT 1 FOR DRY OXYGEN
- PUT 2 FOR STEAM
- PUT 3 FOR NITROGEN
FIELD 3110

THIRD CARD:
CSUR - SUBSTRATE DOPING/1.E15
CS - SURFACE CONCENTRATION/1.E18
TEMP - TEMPERATURE IN DEG. CENT.
TMAX - NORMALIZATION TIME IN SECOND
THIS HAS NO EFFECT IF LAMDA IS SPECIFIED AS DATA
XDIST, YDIST - WIDTH AND THICKNESS (IN MICRON) OF THE TWO
DIMENSIONAL REGION IN QUESTION
OXTHIC - WIDTH (IN MICRON) OF THE OXIDE IN THE REGION
DFLT - NORMALIZED TIME STEP
FORMAT FIELD - 8F10.3

FORTH CARD:
IMTYPE - SPECIFY TYPE OF IMPURITY BY PUTTING N OR P
NO SPEC. IS NECESSARY IF IT IS BORON
IMPUTY - PUT BORON, ARSENIC, PHOSPHOROUS OR ANY
OTHER NAME.
EA - ACTIVATION ENERGY OF THE DIFFUSION
IF BLANK AND BORON DIFF., DATA IS SUPPLIED INTERNALLY
DI - DIFFUSIVITY CONST. OF THE IMPURITY
IF BLANK AND BORON DIFF., DATA IS SUPPLIED INTERNALLY
FIELD A4.44, 2F10.3

FIFTH CARD:
ID - IDENTIFICATION COMMENT TO BE PRINTED ON TOP OF
PROFILE PRINT OUT
ITEST - PUT 0 TO READ LAMDA FROM DATA DECK
CSTOP - CONCENTRATION/1.E15 AT WHICH SIMULATION STOPS
WHEN THE LEFT END CORNER OF SILICON AND SAPPHIRE
INTERFACE REACHES THIS VALUE DURING PREDEP.
FORMAT FIELD - 15A4.15, F15.9

SIXTH CARD (USE IF ISTEP>0):
ROTEMP - REDISTRIBUTION TEMPERATURE
ROTHAX - REDISTRIBUTION NORM. TIME
REDISTRIBUTION FINAL TIME IS 1.
RDDL1 - REDISTRIBUTION NORM. TIME STEP.
XOA - REDISTRIBUTION INITIAL OXIDE THICKNESS IN CM

```

80 C** WHERE SURF. CONC. WAS CS
81 C** XOR - REDISTRIBUTION INITIAL OXIDE THICKNESS IN CM
82 C** WHERE SURF. HAS THE THICK OXIDE
83 C** CM - SEGREGATION COEFFICIENT, GENERATED INTERNALLY IF
84 C** IMPURITY IS BORON AND NO VALUE IS GIVEN
85 C** FIELD 4F10.3
86 C**
87 C** SEVENTH CARD(USE WHEN ITEST=0):
88 C** LAMDA = LAMDA**2/1.E-3
89 C** FORMAT F10.3
90 C**
91 C** EIGHTH CARD(USE IF IREAD=2):
92 C** ION IMPLANTATION DATA
93 C** CMAX = MAX. CONCENTRATION
94 C** RP = RANGE OF DISTRIBUTION, MEAN VALUE (IN MICRON )
95 C** DRP = STRAGGLE, STANDARD DEVIATION, (IN MICRON )
96 C** VOLT = IMPLANTATION ENERGY LEVEL IN KEV
97 C** FIELD 3E15.6,F10.5
98 C**
99 C*****
100 C
101 C IMPLICIT DOUBLE PRECISION (A-H,O-Z)
102 C INTEGER ORINT,AMBNT
103 C DOUBLE PRECISION KB,N1,LAMDA
104 C COMMON /TR1/ A(64),B(64),D(64),E(64),V(64)
105 C COMMON /CON/ CB1(64,64)
106 C DIMENSION X(64),Y(64),CB(64,64),CB2(64,64),G(64,64),ID(15)
107 C DIMENSION IMTYPE(1),IMPITY(4),IRON(4)
108 C DIMENSION XOLAST(4),XD(64),DRRXO(64),VP(64)
109 C DIMENSION IMAT(2),IORN(1),IDOX(2),INIT(2),ISTH(1)
110 C
111 C
112 C
113 C
114 C
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156 C
157 C
158 C
159 C

```

WHERE SURF. CONC. WAS CS
 XOR - REDISTRIBUTION INITIAL OXIDE THICKNESS IN CM
 WHERE SURF. HAS THE THICK OXIDE
 CM - SEGREGATION COEFFICIENT, GENERATED INTERNALLY IF
 IMPURITY IS BORON AND NO VALUE IS GIVEN
 FIELD 4F10.3
 SEVENTH CARD(USE WHEN ITEST=0):
 LAMDA = LAMDA**2/1.E-3
 FORMAT F10.3
 EIGHTH CARD(USE IF IREAD=2):
 ION IMPLANTATION DATA
 CMAX = MAX. CONCENTRATION
 RP = RANGE OF DISTRIBUTION, MEAN VALUE (IN MICRON)
 DRP = STRAGGLE, STANDARD DEVIATION, (IN MICRON)
 VOLT = IMPLANTATION ENERGY LEVEL IN KEV
 FIELD 3E15.6,F10.5

IMPLICIT DOUBLE PRECISION (A-H,O-Z)
 INTEGER ORINT,AMBNT
 DOUBLE PRECISION KB,N1,LAMDA
 COMMON /TR1/ A(64),B(64),D(64),E(64),V(64)
 COMMON /CON/ CB1(64,64)
 DIMENSION X(64),Y(64),CB(64,64),CB2(64,64),G(64,64),ID(15)
 DIMENSION IMTYPE(1),IMPITY(4),IRON(4)
 DIMENSION XOLAST(4),XD(64),DRRXO(64),VP(64)
 DIMENSION IMAT(2),IORN(1),IDOX(2),INIT(2),ISTH(1)

DEFINE COMPUTING FUNCTIONS
 RHS(G,G1,G3,C10,CN0,C20)=C00*G*(G1*C20+G3*C10)
 RATIO(C,CSUR,N1)=(C-CSUR)/(2.*N1)
 ROOT(RATIO)=DSQRT((RATIO**2)+1.0)
 FU(RATIO,ROOT)=((RATIO+ROOT)**2)/ROOT
 CALL ERTRAN (9,DATE,TIME)

READ SIMULATION INITIAL DATA
 READ 360, LIST,IFILE,IFILE,IPL0T,IREAD,JSTEP,IMAXI,JMAXI
 READ 360, JSTP,ORINT,AMBNT
 IF(IREAD.EQ.2) JSTP=1
 READ 370, CSUB,CS,TEMP,TMAX,XDIST,YDIST,OXTHIC,DELT
 READ 320, IMTYPE,IMPITY,EA,DI
 READ 380, ID,ITEST,CSTOP
 IF (JSTP.GT.0) READ (5,370,ERR=310) R0TEMP,R0TMAX,R0DLT,X0A,X0R,CM
 IF (ITEST.EQ.0) READ (5,370,ERR=310) LAMDA

DEFINE DATA:
 KB = BOLTZMANN'S CONSTANT
 JLIM = # OF ALLOWABLE ITERATIONS
 DVLIM = ALLOWABLE ERROR IN CONVERGENCE
 TIMAX = NORMALIZED TIME AT WHICH SIMULATION STOPS
 EAB AND DIB = BORON DIFFUSIVITY DATA

DATA EAB,DIB /3.59D0,1.17D0/
 DATA IBRON /4MBORO,4MM .4M .4M /
 DATA NYP,IPT /1HN,1HP/
 DATA KB /8.616D-5/
 DATA JLIM,DVLIM /60,1.D-8/,TIMAX /1.D0/
 DATA IDOX/6HDIY OX,6HYGEN /
 DATA INIT/6HNITROG,6HFN /
 DATA ISTH/6HSTEAM /

IF (IMPITY.EQ.IRON) IMTYPE=IPT
 IER=0
 IF (JSTP.EQ.1.AND.IREAD.EQ.0) IER=1
 IF (IMPITY.NE.IRON.AND.EA.EQ.0.00) IER=1
 IF (IMPITY.NE.IRON.AND.DI.EQ.0.00) IER=1
 IF (IER.EQ.1) PRINT 450
 IF (IER.EQ.1) GO TO 310
 IF (IMTYPE.EQ.IPT) IMTYPE=0
 IF (IMTYPE.EQ.NYP) IMTYPE=1
 IF (IMPITY.EQ.IRON.AND.EA.EQ.0.00) EA=EAB
 IF (IMPITY.EQ.IRON.AND.DI.EQ.0.00) DI=DIB
 PRINT 410, ID
 PRINT 330, IMPITY,IMTYPE

```

160      NAMELIST /PUT/ LIST,IFILE,LF,LE,IPLT,IREAD,JSTEP,IMAX1,JMAX1,JQTP
161      1,ORINT,AMBNT,CSUB,CS,TEMP,TMAX,XDIST,YDIST,OXTHIC,DELT,EA,DI,ITPST
162      2,CSTOP,LAMDA,ROTFMP,ROTHAX,RODLT,XOA,XOB,CM,JLIM,DVLIM,TMAX
163      WRITE (4,PUT)
164
165      C
166      C
167      C
168      C
169      C
170      C
171      C
172      C
173      C
174      C
175      C
176      C
177      C
178      C
179      C
180      C
181      C
182      C
183      C
184      C
185      C
186      C
187      C
188      C
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223      C
224      C
225      C
226      C
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229      C
230      C
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232      C
233      C
234      C
235      C
236      C
237      C
238      C
239      C

```

REFORMATION OF COMPUTING, GEOMETRIC AND PHYSICAL PARAMETERS

```

      IF (JSTEP.EQ.0.OR.JQTP.GT.1) ICOND=1
      IF (ICOND.EQ.1) AMBNT=1
      IF (AMBNT.NE.3) XDIST=XDIST*1.D-4
      IF (AMBNT.NE.3) YDIST=YDIST*1.D-4
      IF (AMBNT.NE.3) OXTHIC=OXTHIC*1.D-4
      JMAX=JMAX1-1
      KOTI=0
      IMAX=IMAX1-1
      IMAX2=IMAX1+1
      IF (IMAX1.GT.3) GO TO 5
      DELX=6.D0
      IF (AMBNT.NE.3) DELX=6.D-4
      GO TO 4
5     DELX=XDIST/FLOAT(IMAX2-3)
4     DELY=YDIST/FLOAT(JMAX1)
      CSUB=CSUB*1.D15
      CSTOP=CSTOP*1.D15
      LAMDA=LAMDA*1.D-3
      CS=CS*1.D18
      TEMP=273.
      WINDO=(XDIST-OXTHIC)*1.D-5
      CM=CM
      CN=1.0
      TMX=TMAX
      IF (AMBNT.EQ.1) IMAT(1)=IDOX(1)
      IF (AMBNT.EQ.1) IMAT(2)=IDOX(2)
      IF (AMBNT.EQ.2) IMAT=ISTM
      IF (AMBNT.EQ.3) IMAT(1)=INIT(1)
      IF (AMBNT.EQ.3) IMAT(2)=INIT(2)
      IF (ORINT.EQ.1) IORNT=.100
      IF (ORINT.EQ.2) IORNT=.110
      IF (ORINT.EQ.3) IORNT=.111

```

CALCULATE DISTANCE X AND Y

```

      DO 10 I=2,IMAX1
        X(I)=(I-2)*DETX
      10 IF (X(I).LE.WINDO) K=1
      DO 20 J=1,JMAX1
        Y(J)=(J-1)*DELY
      20 DO 30 I=2,IMAX1
        XOLAST(I)=XOA
      30 DO 31 J=JMAX1,1,-1
        YP(J)=(JMAX1-J)*(1./FLOAT(JMAX1))

```

SPECIFY PREDEF CONDITIONS

```

      DO 40 I=1,IMAX2
        DO 40 J=1,JMAX1
          CB(I,J)=0.0
          CB1(I,J)=0.0
          CB2(I,J)=0.0
      40 DO 50 I=2,K
        CB(I,JMAX1)=CS
        CB1(I,JMAX1)=CS
      50 CB2(I,JMAX1)=CS
      TIME=0.0
      LM=0

```

SPECIFY INITIAL PROFILE

```

      IF (IREAD.EQ.2) CALL SUBION(IMAX1,JMAX1,K,Y,YDIST,CSTOP)
      IF (IREAD.EQ.1) CALL XYZ (IMFI,JMFI,X,Y,LM,TIME,KA,DFA,TMP,TMX,JS
      ITP,XOLAST,YDIST,AMBNT)
      IF (IREAD.EQ.1) TMAX=TIME+1.0
      STIME=TIME
      IF (JSTEP.EQ.1) ICOND=2

```

HEAD CONTOUR FRONT MOVEMENT FROM DATA FILE IF IREAD = 1

```

      IF (IREAD.EQ.1) CALL FRONT (IMI,JMI,LA,KC,TMPR,DFA,DLT,LM,I,KOTI,X
      IOST)
      IF (IREAD.EQ.1) PRINT 430, LM,TIME,TMP,DFA,TMX,IMFI,JMFI,KA

```

```

240      IF (IREAD.EQ.1) PRINT 440, TM, DFB, LA, IMI, JMI
241      IF (IREAD.NE.1) GO TO 60
242      IF (IMF1.NE.IMAX1.OR.JMF1.NE.JMAX1.OR.KA.NE.K) IER=1
243      IF (IMI.NE.IMAX1.OR.JMI.NE.JMAX1.OR.KC.NE.K.OR.LA.NE.LM) IER=1
244      IF (IFR.EQ.1) PRINT 450
245      IF (IER.EQ.1) GO TO 310
246
247      C
248      C
249      C
250      60 IF (ICOND.EQ.1) GO TO 70
251      KOTI=0
252      TEMP=RDTEMP
253      T=TEMP+273.
254      DELT=RODLT
255      TMAX=ROTHMX
256      IF (AMRNT.NE.3) DELT=DELT*TMAX
257      IF (AMRNT.NE.3) TMAX=TMAX
258      TIME=0.
259      70 CONTINUE
260
261      C
262      C
263      C
264      CALCULATE NI
265      TMAX=TMAX-DELT
266      CALL PARAM (NI, T)
267      DF=D1*DEXP(-EA/(K* T))
268      IF (ITEST.NE.0) DF=DF*TMAX/((YDIST*1.D-4)**2)
269      IF (AMRNT.NE.3) DF=DF
270      IF (ITEST.EQ.0) DF=LAMDA
271      IF (ICOND.EQ.1) PRINT 340
272      IF (ICOND.EQ.2) PRINT 350
273      PRINT 390, NI, DF
274      PRINT 420, IMPUTY, TEMP, DF, TMAX
275
276      C
277      C
278      C
279      P=(DF*DELT)/(DELY**2)
280      Q=(DF*DELT)/(DELX**2)
281
282      C
283      C
284      C
285      PRINT INITIAL PROFILE
286      CALL OUTPUT (X, Y, TMAX, JMAXI, K, LM, JJ, TIME, YDIST, ID, ITIME, XOLAST,
287      * PTIME, DTIME, AMRNT)
288      IF (IREAD.EQ.2.AND.IFILE.EQ.1) CALL ABC (IMAXI, JMAXI, X, Y, LM, TIME, K,
289      1, DF, TEMP, TMAX, KOTI, XOLAST, YDIST, AMRNT)
290      AM=1.0
291      CC=1.0
292      RB=1.0
293      IF (ICOND.NE.1) CALL OXDATA (AMRNT, ORINT, T, BR,
294      1, CC, AM, KB)
295      IF (ICOND.EQ.2.AND.GM.EQ.0.) CM = AM
296      IF (ICOND.EQ.2.AND.GM.NE.0.) CM = GM
297      IF (ICOND.EQ.2) PRINT 421, IMBT, IORNT, BR, CC, CM
298
299      C
300      C
301      C
302      START TIME STEP LOOP
303      80 LM=LM+1
304
305      C
306      C
307      C
308      STORE N TH. RESULT FOR R.H.S., WILL NOT BE CHANGED DURING ITER.
309
310      C
311      C
312      C
313      TIME=TIME+DELT
314      IF (ICOND.EQ.1) STIME=TIME
315      PTIME=TMX*STIME
316      IF (ICOND.EQ.2) PTIME=TMX
317      DTIME=ROTHMX*(TIME-STIME)
318      IF (AMRNT.NE.3) DTIME=TIME
319      DO 90 I=1, IMAX2
320      DO 90 J=1, JMAX1
321      CR2(I, J)=CR1(I, J)
322      IF (ICOND.EQ.1) GO TO 110
323
324      C
325      C
326      C
327      CALCULATE OXIDE THICKNESS
328      IF (AMRNT.NE.3) GO TO 95
329      DO 94 I=2, IMAX1
330      94 XO(I)=XOLAST(I)
331      GO TO 110
332      95 PS=RB*DELT
333      QS=RR/CC
334      DO 100 I=2, IMAX1
335      XO(I)=XOLAST(I)+PS/(2.*XOLAST(I)+QS)
336      100 ORRXO(I)=(XO(I)-XOLAST(I))/DELT
337      XO(I)=XO(I)
338
339      C
340      C
341      C

```

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320 IF ((YDIST-0.45*X0(1)).LT.0.1D-4) GO TO 310
321 110 CONTINUE
322 DELY=(1./FLOAT(JMAX))* (YDIST-0.45*X0LAST(2))
323 IF (AMRNT.NE.3) P=DF1*DELT/(DELY**2)
324 JJ=0
325 JM=0
326
327 C START ITERATION LOOP
328 C
329 C
330 120 JJ=JJ+1
331 IF (JJ.GT.JLIM) PRINT 400, CTER
332 IF (JJ.GT.JLIM) GO TO 290
333
334 C TRANSFER SOLN. VECTOR FROM LAST ITERA. FOR CAL. OF G
335 C
336 DO 130 I=1,IMAX2
337 DO 130 J=1,JMAX1
338 CR1(I,J)=CR1(I,J)
339
340 C CAL.G
341 C
342 DO 140 I=1,IMAX2
343 DO 140 J=1,JMAX1
344 RA=RATIO(CR1(I,J),CSUB,N1)
345 RO=ROOT(RA)
346 140 G(I,J)=FU(RA,RO)
347
348 C SOLVE SYSTEM IN Y DIRECTION
349 C
350 DO 220 I=2,IMAX1
351 C CALCULATE THE COEFF. IN Y DIRECTION
352 C
353 SR=0.
354 DO 150 J=2,JMAX
355 G1=(G(I,J)+G(I+1,J))/2.0
356 G2=(G(I,J)+G(I,J+1))/2.0
357 G3=(G(I,J)+G(I-1,J))/2.0
358 G4=(G(I,J)+G(I,J-1))/2.0
359 IF (AMRNT.EQ.3) GO TO 151
360 SR=0.45*DRRXO(1)*(YP(J)-1.0)*DELT/DELY
361 151 CONTINUE
362 A(J)=-P*G4
363 R(J)=1.+Q*(G1+G3)+P*(G2+G4)+SR
364 D(J)=-P*G2-SR
365 150 E(J)=RHS(Q,G1,G3,CSB(I-1,J),CR2(I,J),CSB(I+1,J))
366
367 C PUT BOUNDARY CONDITION ON Y AXIS
368 C
369 R(2)=A(2)+R(2)
370 A(2)=0.0
371 IF (ICOND.NE.1) GO TO 170
372 IF (I.GT.K) GO TO 140
373 E(JMAX)=E(JMAX)-D(JMAX)*CS
374 D(JMAX)=0.0
375 GO TO 180
376 160 CONTINUE
377 B(JMAX)=B(JMAX)+D(JMAX)
378 D(JMAX)=0.0
379 GO TO 180
380 170 IF (AMRNT.EQ.3) DRRXO(1)=0.
381 HA=-DELY*(1./CH-0.45)*DRRXO(1)
382 HB=2.*DF1
383 HK1=HA/(HB*G(1,JMAX1))
384 HK2=HA/(HB*G(1,JMAX))
385 B(JMAX)=B(JMAX)*((1.+HK2)/(1.-HK1))+D(JMAX)
386 D(JMAX)=0.
387 180 CONTINUE
388
389 C CALL TRIDAG (2,JMAX)
390 C
391 C CONVERT MATRIX SOLUTION
392 C
393 DO 190 J=2,JMAX
394 CR1(I,J)=V(J)
395 190 CONTINUE
396
397 C PUT BOUNDARY VALUES IN V
398 C
399 CR1(I,1)=CR1(I,2)

```

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400      IF (ICOND.NE.1) GO TO 210
401      IF (1.GT.K) GO TO 290
402      CR(1,JMAX1)=CS
403      GO TO 220
404      200  CR(1,JMAX1)=CR(1,JMAX)
405      GO TO 220
406      210  CONTINUE
407      CR(1,JMAX1)=((1.+HK2)/(1.+HK1))*CR(1,JMAX)
408      IF (CR(1,JMAX1).LT.1.D-300) CR(1,JMAX1)=1.D-300
409      220  CONTINUE
410  C
411  C      PUT BOUNDARY VALUES IN AXIS X(PERIODIC BOUNDARY)
412  C
413      DO 230 J=1,JMAX1
414      CR(1,J)=CR(1,1)
415      230  CR(1MAX2,J)=CR(1MAX,J)
416  C
417  C      CHECK FOR CONVERGENCE
418  C
419      IF (JJ.EQ.1) GO TO 120
420      ICK=0
421      DO 240 I=1,1MAX1
422      DO 240 J=1,JMAX
423      IF (CR(1,J).E.0.0) GO TO 240
424      CTEST=DABS((CR(1,J)-CR(1,J))/CR(1,J))
425      IF (CTEST.LE.DVLM) GO TO 240
426      CTER=DMAX1(CTEST,CTER)
427      ICK=1
428      240  CONTINUE
429      IF (ICK.NE.0) GO TO 120
430      JH=JH+1
431      DO 241 I=1,1MAX1
432      DO 241 J=1,JMAX1
433      241  IF (CR(1,J).LT.0.D) CR(1,J)=CR(1,J)
434      IF (JH.EQ.1) GO TO 120
435  C
436  C      PRINT RESULTS
437  C
438      IS=LM/LIST*LIST-LM
439      IF (IS.EQ.0) GO TO 250
440      IF (TIME.GE.TIMAX.AND.CS.NE.0.0) GO TO 250
441      IF (CR(2,1).GE.CSTOP.AND.ICOND.EQ.1) GO TO 250
442      IF (CR(2,1).GE.CSTOP.AND.CS.EQ.0.0.AND.JSTEP.EQ.1) GO TO 250
443      GO TO 240
444      250  CALL OUTPUT (X,Y,1MAX1,JMAX1,K,LM,JJ,TIME,YDIST,IN,ITIME,XO,
445      * PTIME,DTIME,AMBN)
446      CALL SHREJN (CSUR,YDIST,JMAX1,Y,TIME,DELT,DELT,TEMP,TMAX,IFILF,ITY
447      IPE,AMRNT,XO(2))
448      IF (IPLOT.NE.1) GO TO 260
449      CALL PLOT (CS,1MAX1,JMAX1,K)
450  C
451  C      STORE TRANSIENT DATA
452  C
453      260  IF (IFILE.EQ.0) GO TO 270
454      IT=LM/LFILE*LFILE-LM
455      IF (IT.EQ.0) GO TO 265
456      IF (TIME.GE.TIMAX) GO TO 265
457      IF (CR(2,1).GE.CSTOP.AND.ICOND.EQ.1) GO TO 265
458      GO TO 266
459      265  CALL ABC(1MAX1,JMAX1,X,Y,LM,TIME,
460      IK,DFI,TEMP,TMAX,KOTI,XO,YDIST,AMRNT)
461  C
462  C      LOCATE CONTOUR POSITION AND STORE DATA
463  C
464  C
465      266  CONTINUE
466      CALL FRONT (1MAX1,JMAX1,LM,K,TEMP,DFI,DELT,JSTEP,D,KOTI,XDIST)
467      270  CONTINUE
468  C
469  C      GO TO NEXT TIME STEP
470  C
471      IF (CR(2,1).GE.CSTOP.AND.ICOND.EQ.1) GO TO 290
472      IF (TIME.GE.TIMAX) GO TO 290
473      XO(1)=XO(2)
474      DO 280 I=2,1MAX1
475      280  XOLAST(1)=XO(1)
476      GO TO 80
477      290  IF (JSTEP.GT.1.AND.ICOND.EQ.1) GO TO 300
478      GO TO 310
479      300  TIMAX=TIME+1.

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480      IF (AMNT.NE.3) TIME=TIME+DTIME
481      ICOND=2
482      GO TO 40
483 310  IF (LM.EQ.0) PRINT 450
484      STOP
485
486  C
487 320  FORMAT (A4,4A4,2F10.3)
488 330  FORMAT (1H0.20X,'IMPURITY = ',4A4.2X,'IMPURITY TYPE = ',A4)
489 340  FORMAT (1H0.20X,'*** PREDEPOSITION CYCLE ***')
490 350  FORMAT (1H1.20X,'*** REDISTRIBUTION CYCLE ***')
491 360  FORMAT (8I10)
492 370  FORMAT (8E10.5)
493 380  FORMAT (15A4,15,F15.9)
494 390  FORMAT (//,1H0.10X,'NI = ',D10.3,5X,'DFI = ',D10.3//)
495 400  FORMAT (//,1H0.10X,'ITERATION DID NOT CONVERGE, ERROR = ',D10.3)
496 410  FORMAT (1H1.10X,'*** SOLUTION OF DIFFUSION PROBLEM FOR SILICON,
497      1 ON SAPPHIRE ***//,1H0.31X,'NORMALIZED SOLUTION'//,1H .10X,'15A4//)
498 2H0.10X,'FOLLOWING ARE THE DATA VALUES')
499 420  FORMAT (//,1H0.10X,'NI = INTRINSIC CARRIER CONC.//,1H .10X,'DFI =
500      1 INTRINSIC DIFFUSIVITY OF ',1X,4A4.2X,'AT ',2X,F10.3,2X,'DEG. CENT.
501      2//,1H .10X,'LAMBDA = LAMBDA**2 = DFI*TMAX/LYMAX',E+4.2//,1H .10X,
502      3'LAMBDA = ',D10.3,5X,'FOR NORMALIZATION TIME = ',E12.6,2X,'SEC.')
503 421  FORMAT (//,1H0.10X,'AMBIENT = ',2A4/1H0.5X,'CRYSTAL ORIENTATION = ',
504      4A4//,1H0.5X,'OXIDATION PARAMETERS:',5X,2X,'B = ',
505      5E10.3,2X,'C = ',F10.3,
506      6'1H0.5X,'SEGREGATION COEFF. = ',E10.3)
507 430  FORMAT (1H0.10X,'*** INITIAL PROFILE AT TIME STEP = ',15.2X,'TIME
508      1 = ',D10.3,2X,'HAS BEEN READ IN FROM DATA FILE 11 ***//,1H0.15X,'FOI
509      2LOWING DATA ARE PROVIDED'//,1H .15X,'TEMP = ',D10.3,2X,'LAMBDA**2 =
510      3 ',D10.3,2X/1H .15X,'NORM. TIME = ',D10.3,2X,'IMAXI = ',110.2X,'JW
511      4AXI = ',110.2X,'OXIDE GRID = ',16)
512 440  FORMAT (1H0.10X,'*** FOLLOWING DATA ARE OBTAINED FROM THE DATA
513      1 FILE 9 ***//,1H .10X,'TEMP = ',F10.3/1H .10X,'LAMBDA**2 = ',D10.
514      23/1H .10X,'TIME STEP = ',110/1H .10X,'IMAXI = ',15/1H .10X,'JMAXI
515      3 = ',15)
516 450  FORMAT (1H0.10X,'***DATA INPUT ERROR ***//,1H0.8X,'RUNSTREAM TERMIN
517      1ATED')
518  C
519      END

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GPRT 5059.SWREJN:MAIN-PLOT

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MICRON=5052(1).SHRFJN
1  SUBROUTINE SHREJN(CSUR,YDIST,JMAX1,X,TIME,DELT,DELY,
2  * TEMP,TMAX,IFILE,ITYPE,IAMBNT,XO)
3  C.....
4  C..... SURROUTINE FOR CALCULATING SHEET RESISTANCE AND JUNCTION
5  C.....
6  IMPLICIT DOUBLE PRECISION(A-H,O-Z)
7  COMMON /CON/C(64,4)
8  DIMENSION CNET(64),CRI(64),X(1),Y(64)
9  DEL=YDIST/FLOAT(JMAX1-1)
10 IF(IAMBNT.NE.3) DEL=DEL/YDIST
11 YWJ=0.0
12 YWJ1=0.0
13 DO 4 I=1,JMAX1
14 IJ=JMAX1-I+1
15 Y(I)=YDIST-X(IJ)
16 6 IF(IAMBNT.NE.3) Y(I)=(I-1)*(1./FLOAT(JMAX1-1))
17 JN1=1
18 ICK=0
19 DO 5 J=JMAX1,1,-1
20 I=JMAX1+1-J
21 CRI(I)=C(2,J)
22 IF(CRI(I).LT.CSUR.AND.ICK.EQ.0) JN1=1
23 IF(CRI(I).GT.CSUB) ICK=1
24 IF(CRI(I).GT.CSUR) JN=1
25 5 CNET(I)=CRI(I)-CSUB
26 IF(JN1.EQ.1.OR.JN.EQ.(JMAX1-1).OR.JN.EQ.JMAX1) GO TO 7
27 YWJ=(YDIST/(JMAX1-1))*(CBI(JN)-CSUB)/(CBI(JN)-CBI(JN+1))
28 IF(IAMBNT.NE.3) YWJ=YWJ/YDIST
29 YWJ1=DEL*(CSUB-CRI(JN1))/(CBI(JN1+1)-CBI(JN1))
30 7 K=0
31 SIGMA=0.000
32 Q=0.00
33 C
34 C START INTEGRATION
35 C
36 1 K=K+1
37 IF(K.GE.JMAX1) GO TO 2
38 Q=Q+(CBI(K+1)+CBI(K))*DEL/2.0
39 IF(K.LE.JN1.OR.K.GE.JN) GO TO 1
40 SIG1=G(DABS(CNET(K)),ITYPE)
41 SIG2=G(DABS(CNET(K+1)),ITYPE)
42 SIGMA=SIGMA+(Y(K+1)-Y(K))*(SIG2+SIG1)/2.000
43 GO TO 1
44 2 CONTINUE
45 IF(JN.EQ.JMAX1) YWJ=0.0
46 IF(JN1.EQ.1.AND.CRI(JN1).GT.CSUR) YWJ1=0.0
47 SIGA=G(DABS(CNET(JN+1)),ITYPE)
48 SIGB=G(DABS(CNET(JN1)),ITYPE)
49 SIGC=G(DABS(CNET(JN1+1)),ITYPE)
50 YJUNC=Y(JN)+YWJ
51 SIGIN=G(DABS(CNET(JN)),ITYPE)
52 SIGWJ=0.5*(YWJ*(SIGIN+SIGA)+(DEL-YWJ1)*(SIGB+SIGC))
53 YWJ1=Y(JN1)+YWJ1
54 SIGMA=SIGMA+SIGWJ
55 RS=1.000/SIGMA
56 WRITE(6,203) YWJ1,YJUNC,RS,Q
57 203 FORMAT(1/5X,'JUNCTION IS AT ',2D15.9,' CM',5X,/,
58 * 5X,'SHEET RESISTANCE = ',D15.9,3X,
59 * /3X,'INTEGRATED IMPURITY=',D15.9)
60 WRITE(6,201) JN1,JN
61 201 FORMAT(10/5X,'JN=',2I5/)
62 AFAC=1.0
63 IF(IAMBNT.NE.3) AFAC=(YDIST-0.45*X0)/1.0-4
64 YJUNC=YJUNC*AFAC
65 RS=RS/(AFAC*1.0-4)
66 Q=Q*AFAC*1.0-4
67 IF(IFILE.EQ.1) CALL SWFILE(TIME,DELT,DELY,TEMP,
68 * TMAX,RS,YWJ1,YJUNC,JMAX1,YDIST,XO,IAMBNT)
69 RETURN
70 END

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ORIGINAL PAGE IS
OF POOR QUALITY

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80      DO 30 I=1,19
81      X=0.4*FLOAT(I)
82      LNWT=3
83      IF (MOD(I,5).EQ.0) LNWT=+1
84      CALL PLOT(X,0.0,3)
85      CALL PLOT(X,YMAX,2,LNWT)
86      30 CONTINUE
87      C* HORIZONTAL AXIS NUMBERS
88      DEX=XP/20.
89      IE=21
90      IG=1
91      IF(DEX.LT.0.1) IE=11
92      IF(DEX.LT.0.1) IG=2
93      IF(DEX.LT.0.01) DEX=XP/10.
94      IF(IAMBNT.EQ.3) GO TO 31
95      IG=1
96      DEX=XP/20.
97      IE=21
98      31 CONTINUE
99      DO 40 I=1,IE
100     VAL=DEX*FLOAT(I-1)
101     X=0.4*FLOAT(I-1)-1.5*HGT+0.04
102     Y=0.2
103     CALL NUMBER(X,Y,HGT,VAL,0.0,16)
104     40 CONTINUE
105     C* VERTICAL AXIS NUMBERS
106     IF(IAMBNT.NE.3) YAK=YC(JK)/1.E-4
107     DEY=YAK/10.
108     DO 50 I=1,11
109     VAL=DEY*FLOAT(I-1)
110     X=-3.0*HGT+0.1
111     Y=YMAX-0.4*FLOAT(I-1)-0.5*HGT
112     CALL NUMBER(X,Y,HGT,VAL,0.0,1)
113     50 CONTINUE
114     CALL SYMBOL(4.2,5.7,0.1,-1.0E20,0.0,0.8)
115     CALL SYMBOL(4.2,5.5,0.1,-1.0E19,0.0,0.8)
116     CALL SYMBOL(4.2,5.3,0.1,-1.0E18,0.0,0.8)
117     CALL SYMBOL(4.2,5.1,0.1,-1.0E17,0.0,0.8)
118     CALL SYMBOL(4.2,4.9,0.1,-1.0E16,0.0,0.8)
119     CALL SYMBOL(4.2,4.7,0.1,-1.0E15,0.0,0.8)
120     CALL SYMBOL(4.0,5.7,0.1,0.0,0.0,-1)
121     CALL SYMBOL(4.0,5.5,0.1,1.0,0.0,-1)
122     CALL SYMBOL(4.0,5.3,0.1,2.0,0.0,-1)
123     CALL SYMBOL(4.0,5.1,0.1,3.0,0.0,-1)
124     CALL SYMBOL(4.0,4.9,0.1,4.0,0.0,-1)
125     CALL SYMBOL(4.0,4.7,0.1,5.0,0.0,-1)
126     CALL SYMBOL(0.0,5.4,0.2,0.0,0.0,-1) = '0.0,14)
127     CALL SYMBOL(0.0,5.4,0.2,41.0,0.0,-1)
128     CALL SYMBOL(999.9,5.1,0.2,0.0,0.0,-1)
129     CALL NUMBER(2.6,5.4,0.2,DP1,0.0,4)
130     CALL SYMBOL(0.0,5.1,0.2,'TEMPERATURE' = '0.0,14)
131     CALL NUMBER(2.6,5.1,0.2,TEMP,C.0.0)
132     CALL SYMBOL(0.0,4.8,0.2,'TIME STEP' = '0.0,14)
133     TLM=LH
134     CALL NUMBER(2.6,4.8,0.2,TLM,0.0,-1)
135     CALL SYMBOL(0.0,4.5,0.2,'TIME' = '0.0,14)
136     CALL NUMBER(2.6,4.5,0.2,TIME,0.0,2)
137     DO 200 I=1,6
138     CONVAL=10.0*FLOAT(20+I+1)
139     CALL PLTCONICR,CONVAL,11,1K,JK)
140     200 CONTINUE
141     CALL PLOT(0.0,0.0,999)
142     100 CONTINUE
143     STOP
144     END

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6FIN